

Towards increased efficiency in solar energy harvesting via intermediate states

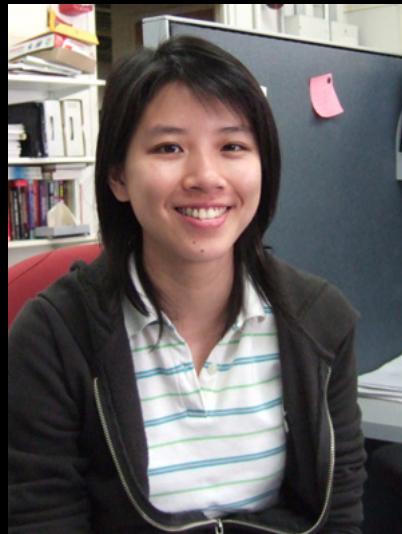


Ben Franta
PACRIM 2013
Coronado, CA, 6 June 2013





Renee Sher



Yu-Ting Lin



Kasey Philips



Ben Franta



eric_mazur

and also....

Marc Winkler

Eric Diebold

Haifei Albert Zhang

Dr. Brian Tull

Dr. Jim Carey (SiOnyx)

Prof. Tsing-Hua Her (UNC Charlotte)

Dr. Shrenik Deliwala

Dr. Richard Finlay

Dr. Michael Sheehy

Dr. Claudia Wu

Dr. Rebecca Younkin

Prof. Catherine Crouch (Swarthmore)

Prof. Mengyan Shen (Lowell U)

Prof. Li Zhao (Fudan U)

Dr. Elizabeth Landis

Dr. John Chervinsky

Prof. Alan Aspuru-Guzik

Prof. Michael Aziz

Prof. Michael Brenner

Prof. Cynthia Friend

Prof. Howard Stone

Prof. Tonio Buonassisi (MIT)

Prof. Silvija Gradecak (MIT)

Prof. Jeff Grossman (MIT)

Dr. Bonna Newman (MIT)

Joe Sullivan (MIT)

Matthew Smith (MIT)

Prof. Augustinus Asenbaum (Vienna)

Dr. François Génin (LLNL)

Mark Wall (LLNL)

Dr. Richard Farrell (RMD)

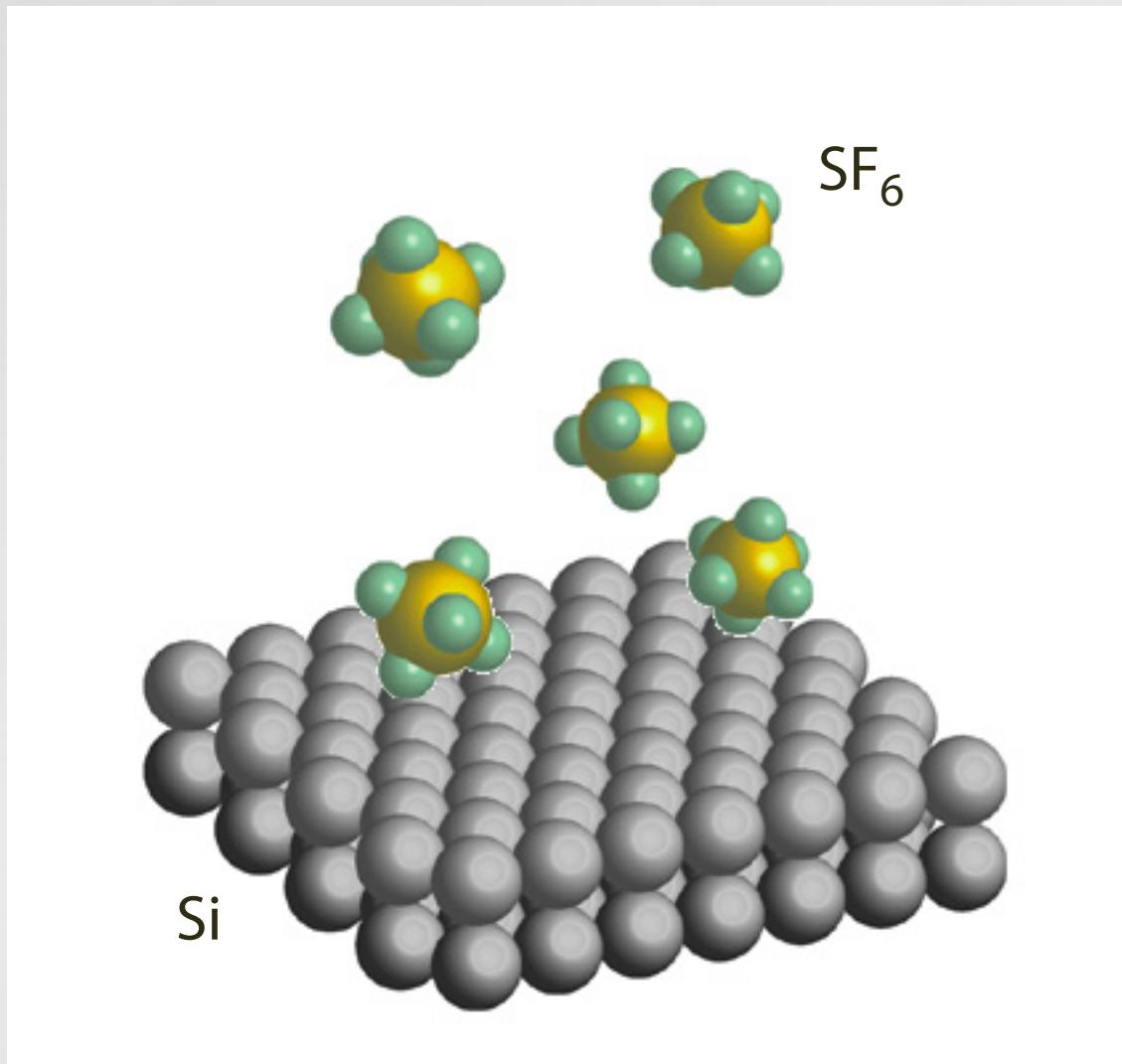
Dr. Arieh Karger (RMD)

Dr. Richard Meyers (RMD)

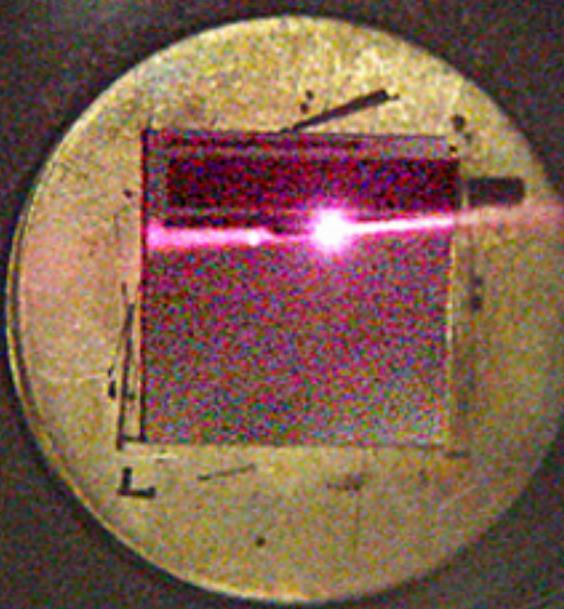
Dr. Pat Maloney (NVSED)

Dr. Jeffrey Warrander (ARDEC)

...and the people at SiOnyx

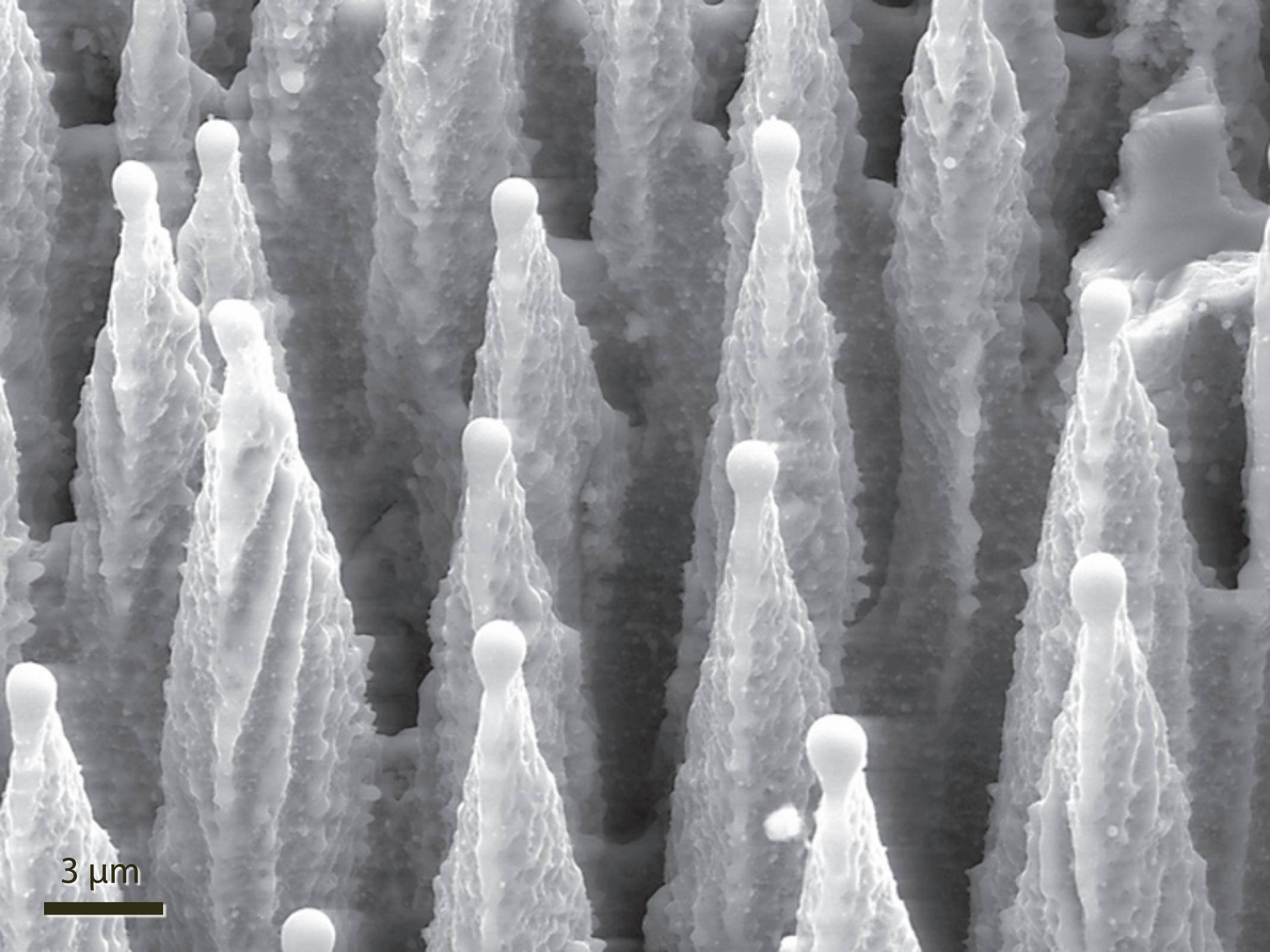


irradiate with 100-fs 10 kJ/m² pulses



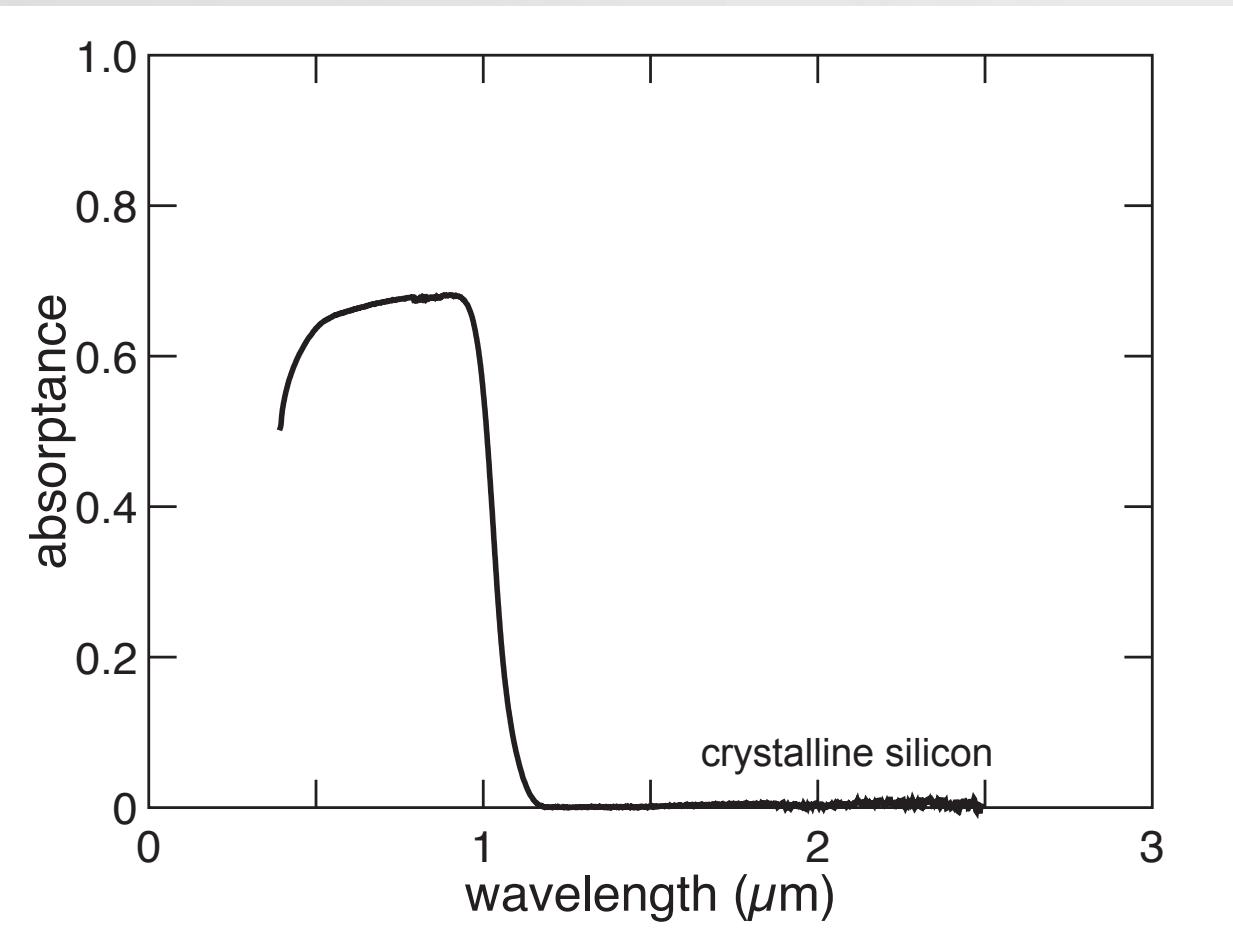


"black silicon"

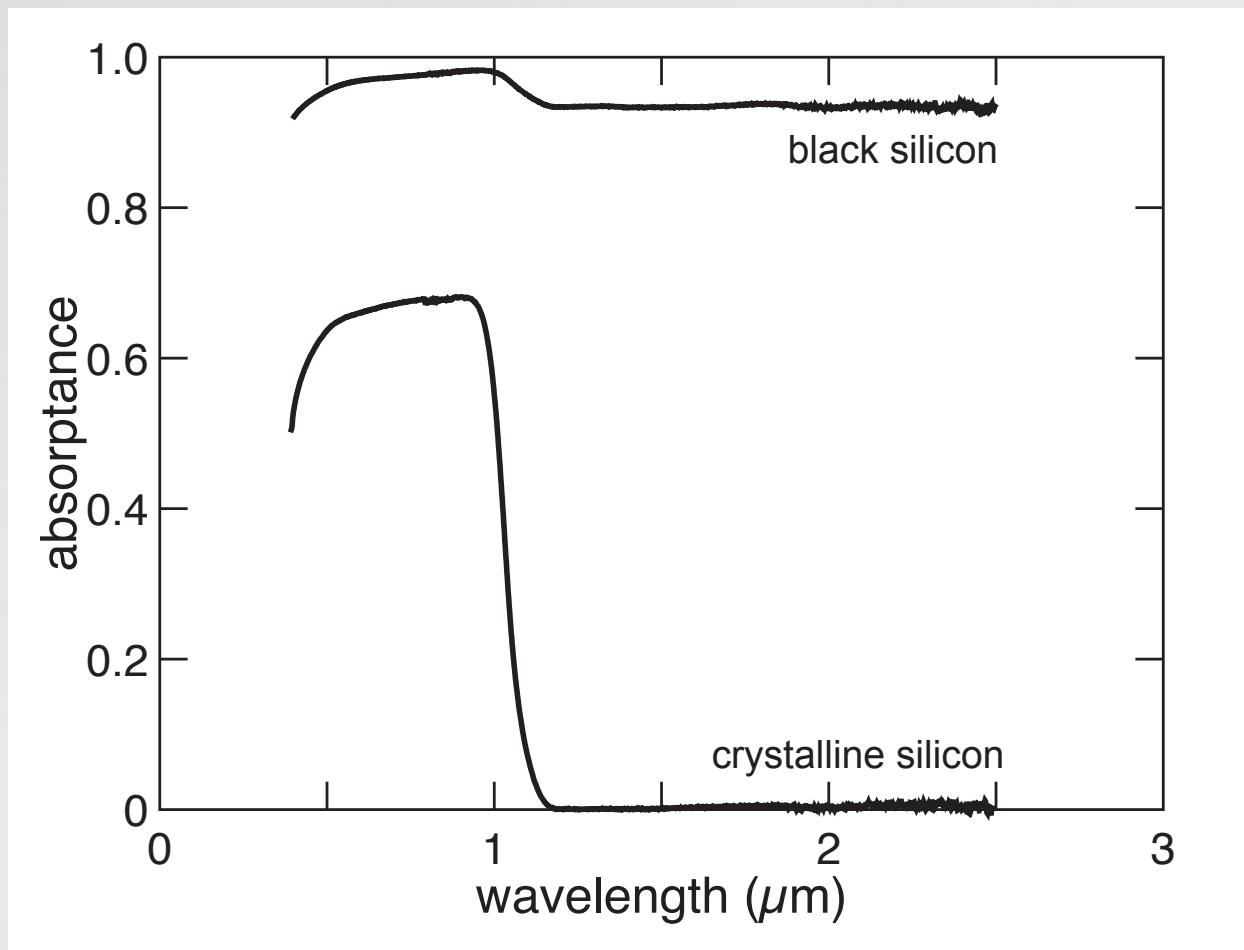


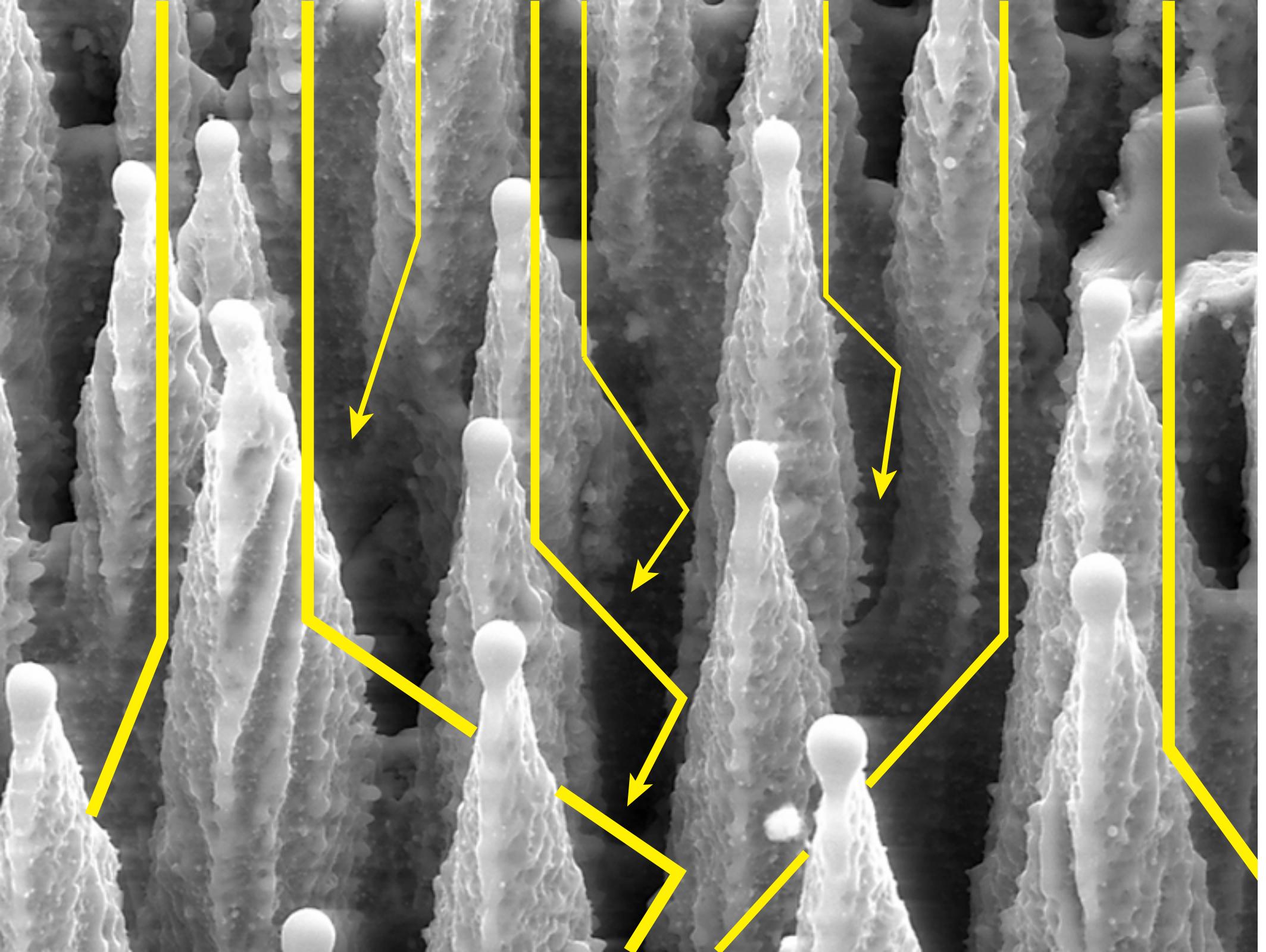
3 μ m

absorptance ($1 - R_{\text{int}} - T_{\text{int}}$)

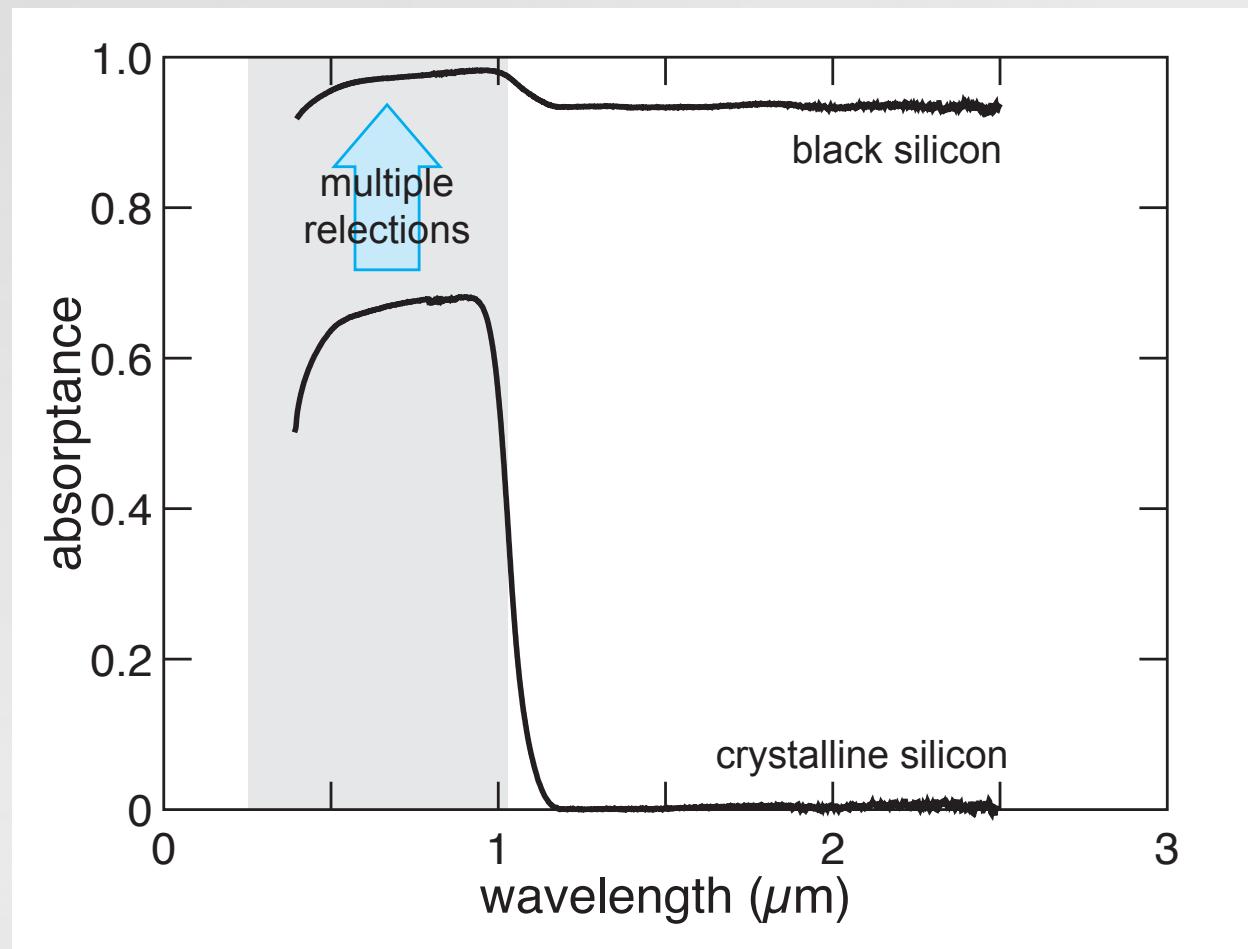


absorptance ($1 - R_{\text{int}} - T_{\text{int}}$)

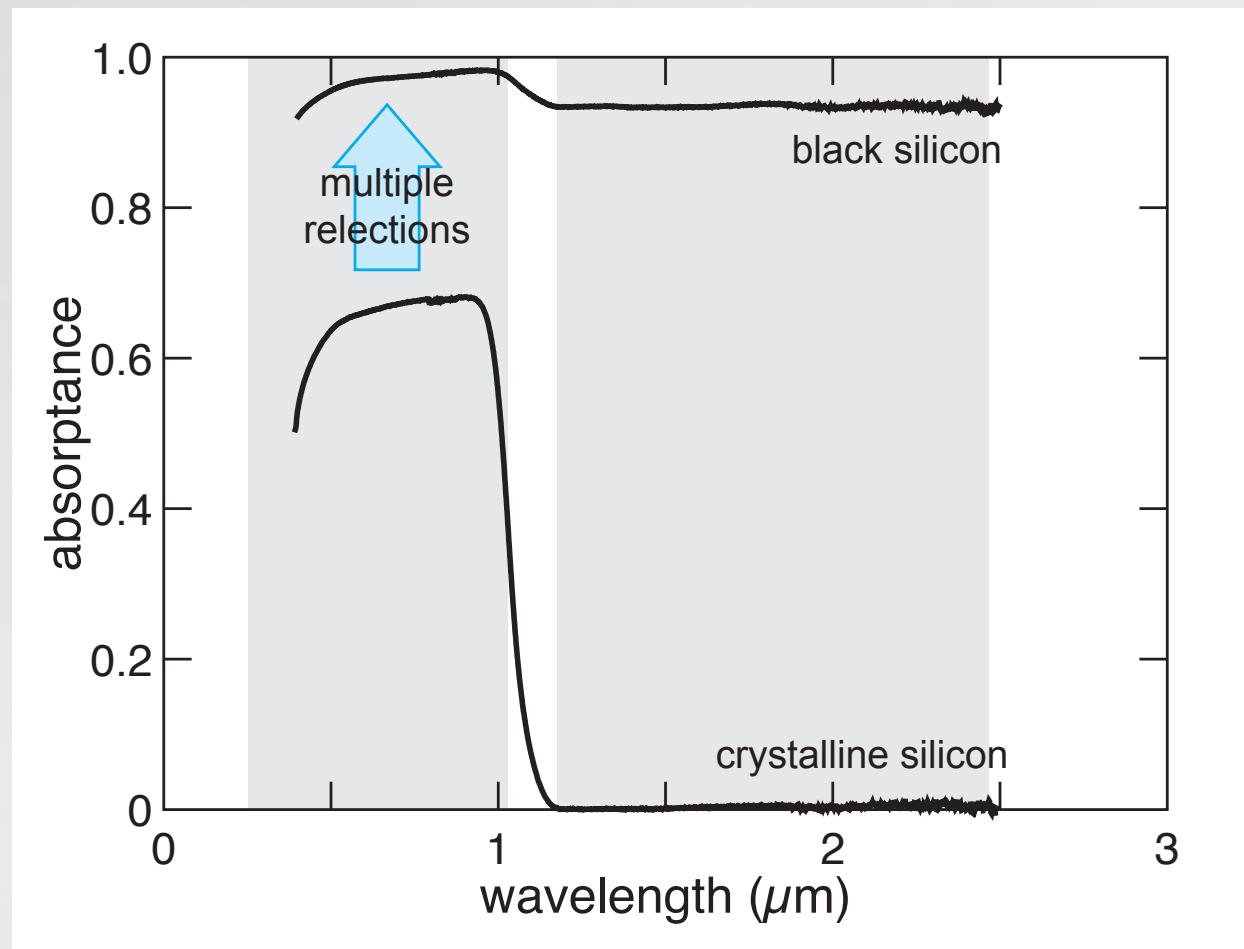




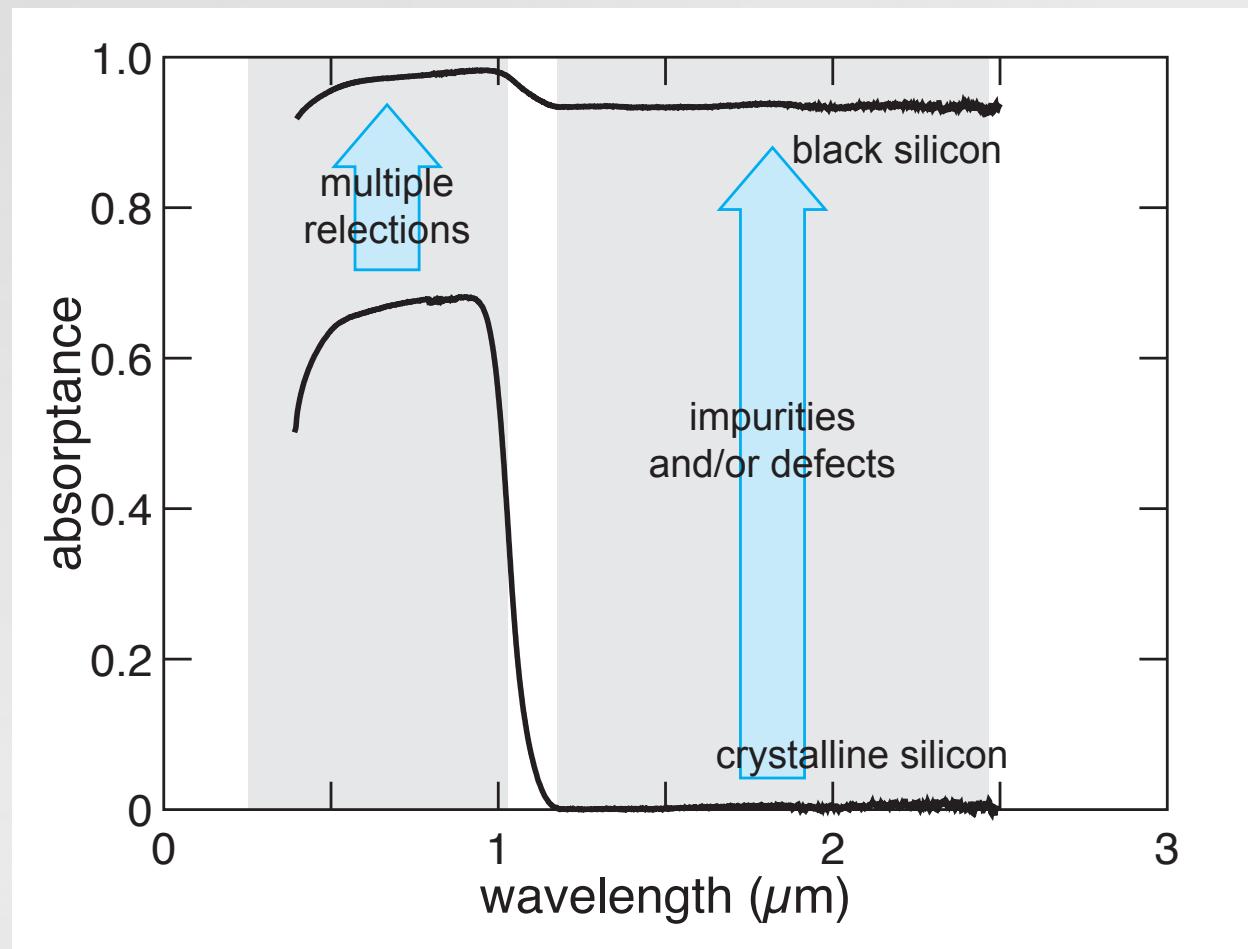
$$\text{absorptance} (1 - R_{\text{int}} - T_{\text{int}})$$

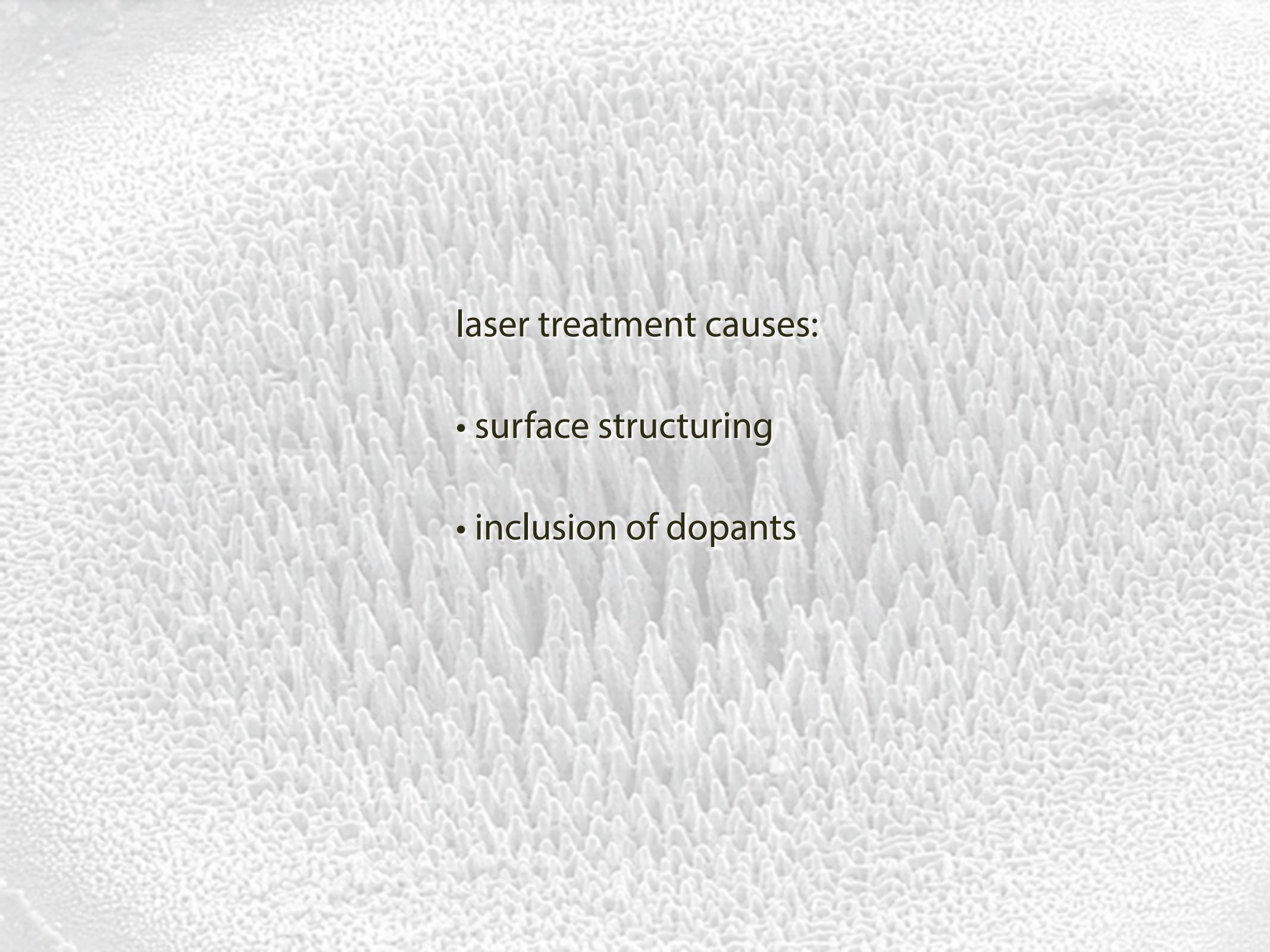


$$\text{absorptance} (1 - R_{\text{int}} - T_{\text{int}})$$



absorptance ($1 - R_{int} - T_{int}$)





laser treatment causes:

- surface structuring
- inclusion of dopants

substrate/dopant combinations

dopants:

I	II	III	IV	V	VI	VII	VIII										
H	Be	B	C	N	O	F	He										
Li	Mg	Al	Si	P	S	Cl	Ne										
Na		Ga	Ge	As	Se	Br	Kr										
K	Ca	Sc	Ti	V	Cr	Mn	Fe	Co	Ni	Cu	Zn	In	Sn	Sb	Te	I	Xe
Rb	Sr	Y	Zr	Nb	Mo	Tc	Ru	Rh	Pd	Ag	Cd						

substrates:

Si

substrate/dopant combinations

dopants:

I	II	III	IV	V	VI	VII	VIII										
H	Be	B	C	N	O	F	He										
Li	Mg	Al	Si	P	S	Cl	Ne										
Na		Ga	Ge	As	Se	Br	Ar										
K	Ca	Sc	Ti	V	Cr	Mn	Fe	Co	Ni	Cu	Zn	Ga	Ge	As	Se	Br	Kr
Rb	Sr	Y	Zr	Nb	Mo	Tc	Ru	Rh	Pd	Ag	Cd	In	Sn	Sb	Te	I	Xe

substrates:

Si

substrate/dopant combinations

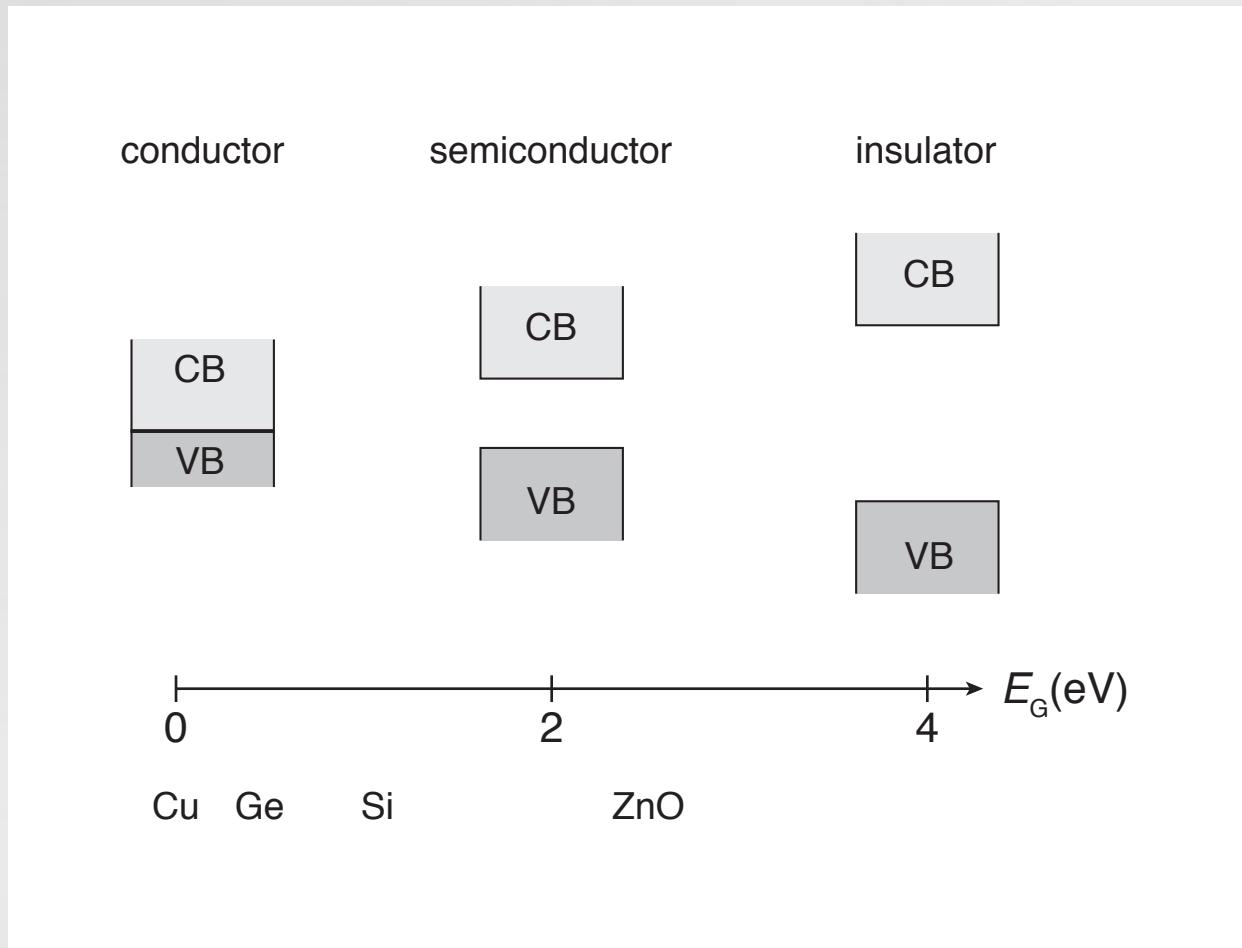
dopants:

I	II	III	IV	V	VI	VII	VIII										
H	Be	B	C	N	O	F	He										
Li	Mg	Al	Si	P	S	Cl	Ne										
Na		Ga	Ge	As	Se	Br	Ar										
K	Ca	Sc	Ti	V	Cr	Mn	Fe	Co	Ni	Cu	Zn	Ga	Ge	As	Se	Br	Kr
Rb	Sr	Y	Zr	Nb	Mo	Tc	Ru	Rh	Pd	Ag	Cd	In	Sn	Sb	Te	I	Xe

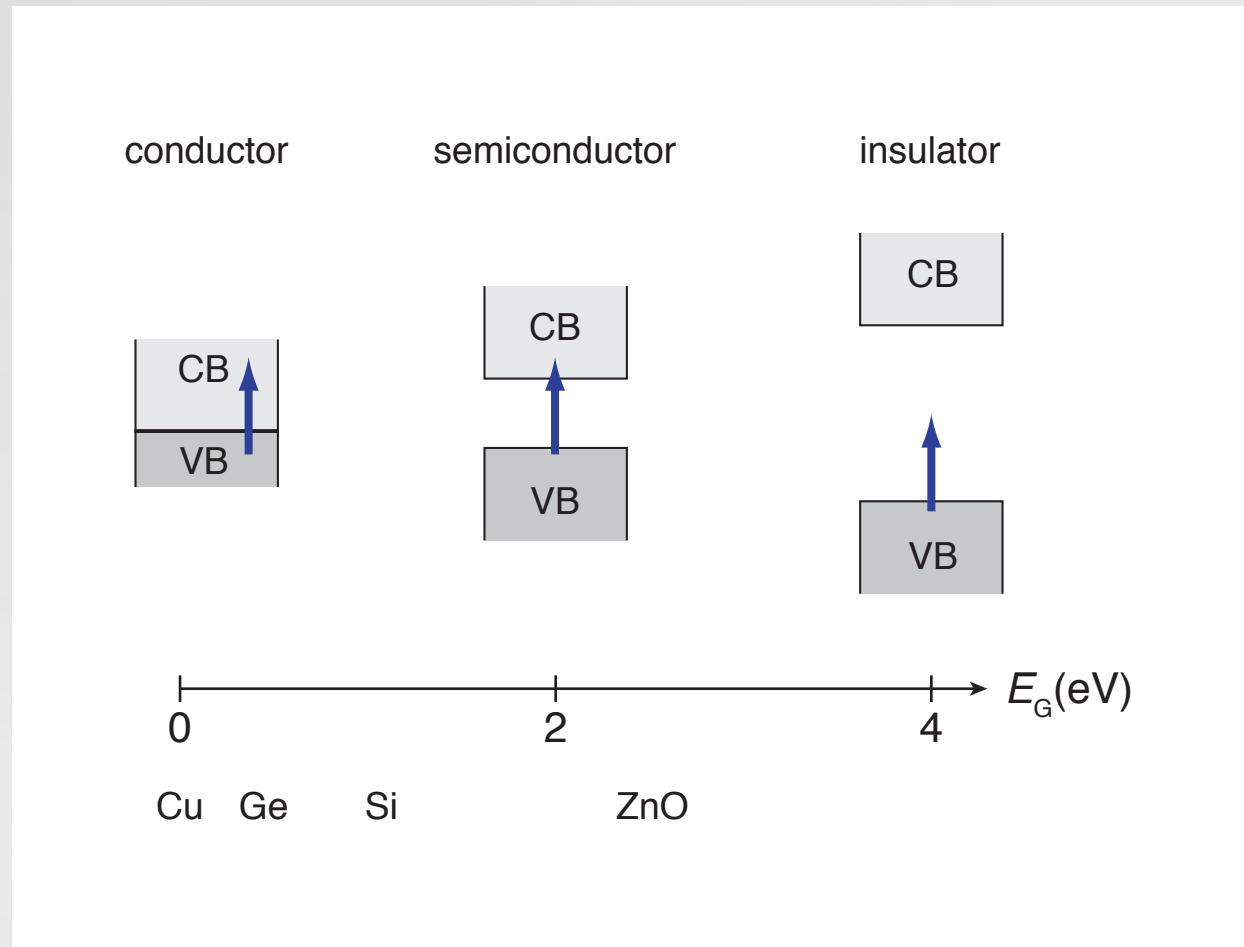
substrates:

Si Ge ZnO InP GaAs

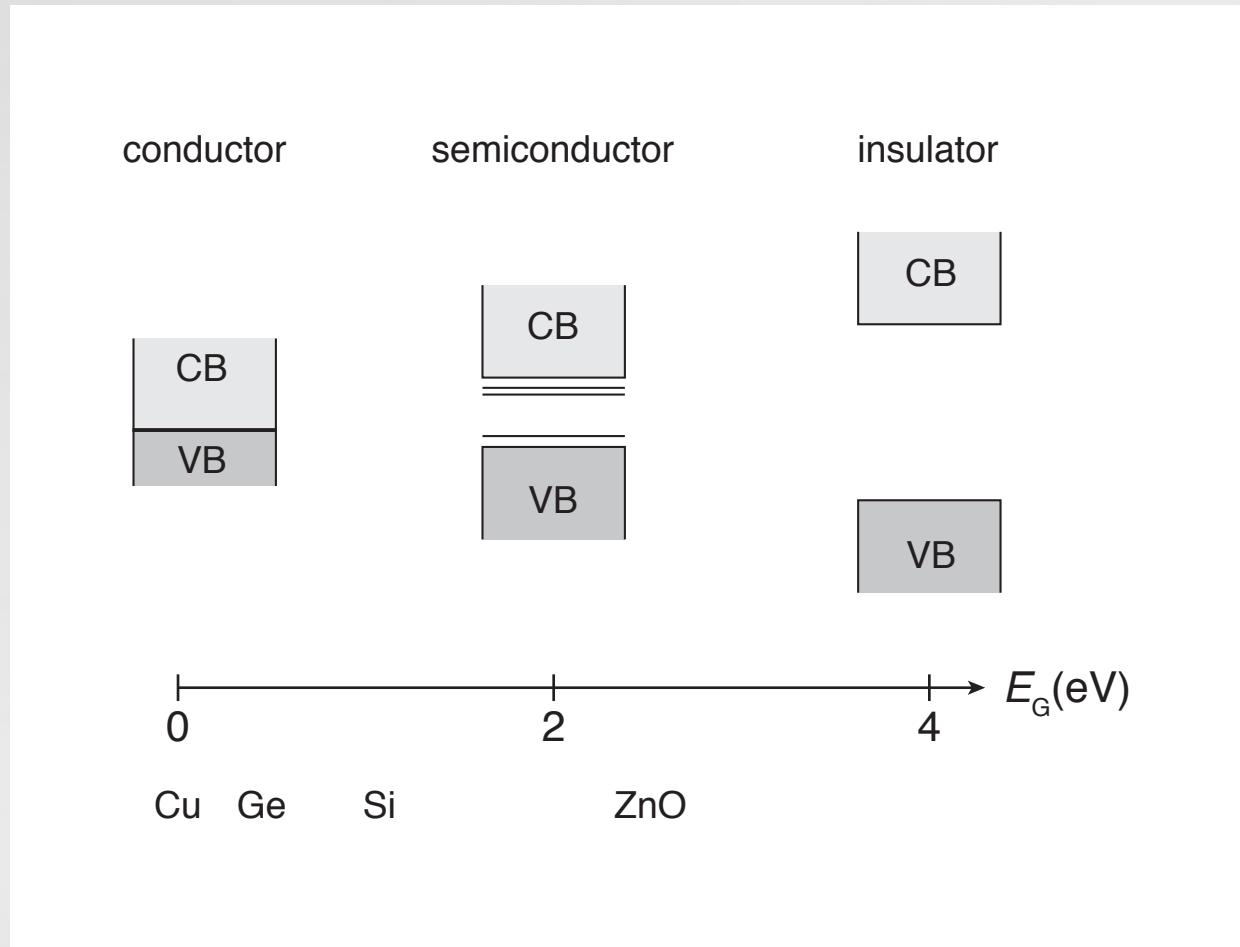
Ti Ag Al Cu Pd Rh Ta Pt TiO₂



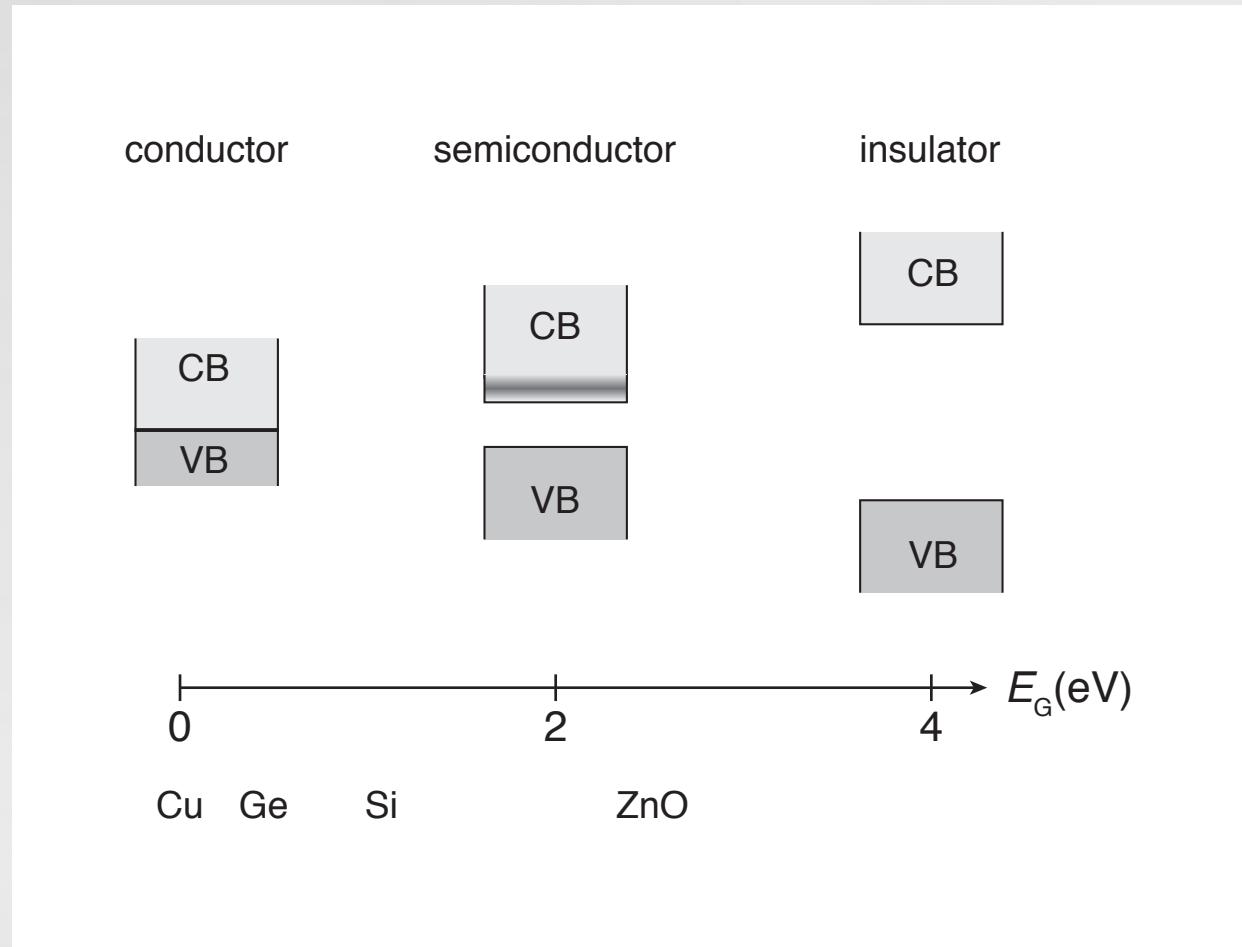
gap determines optical and electronic properties



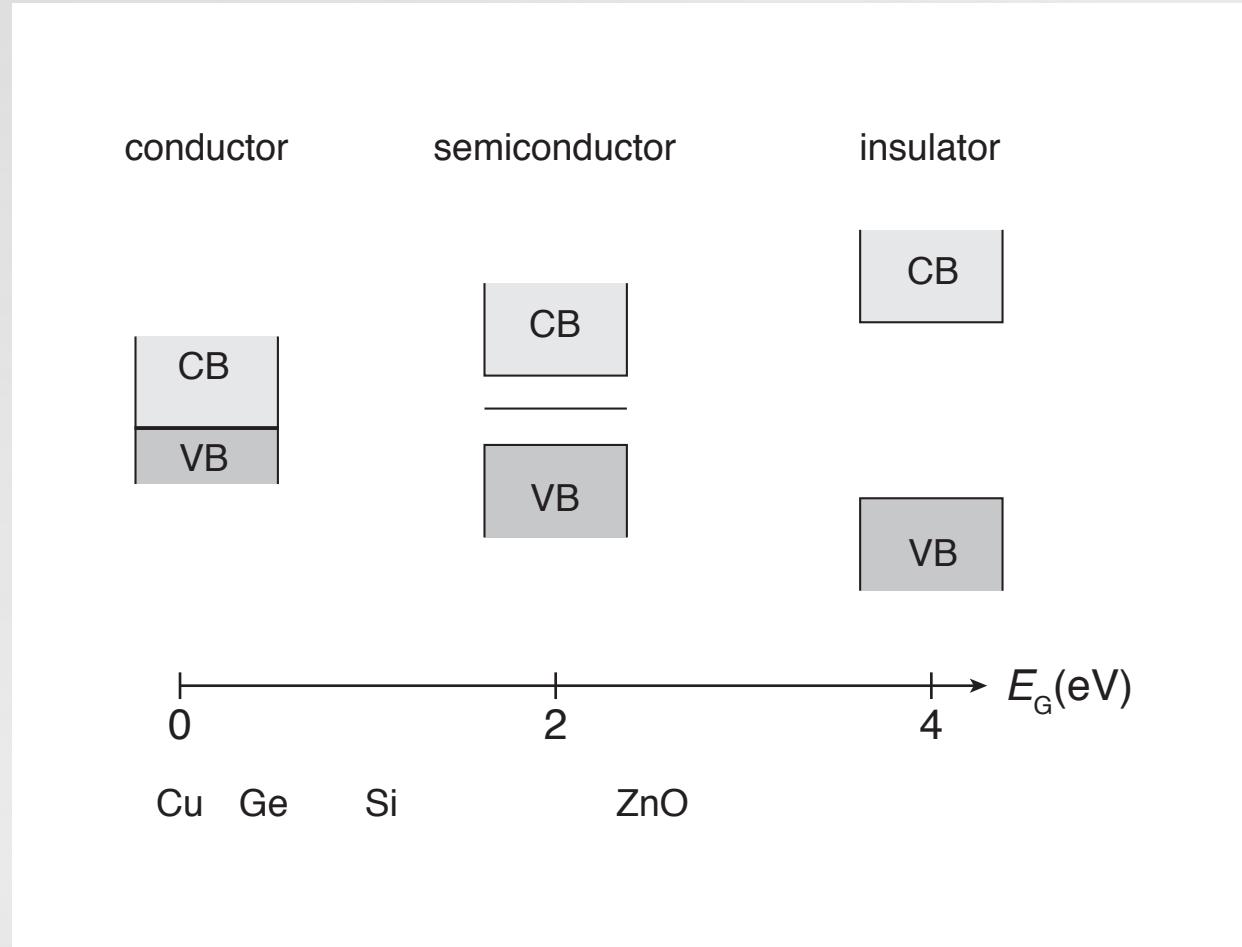
shallow-level dopants control electronic properties



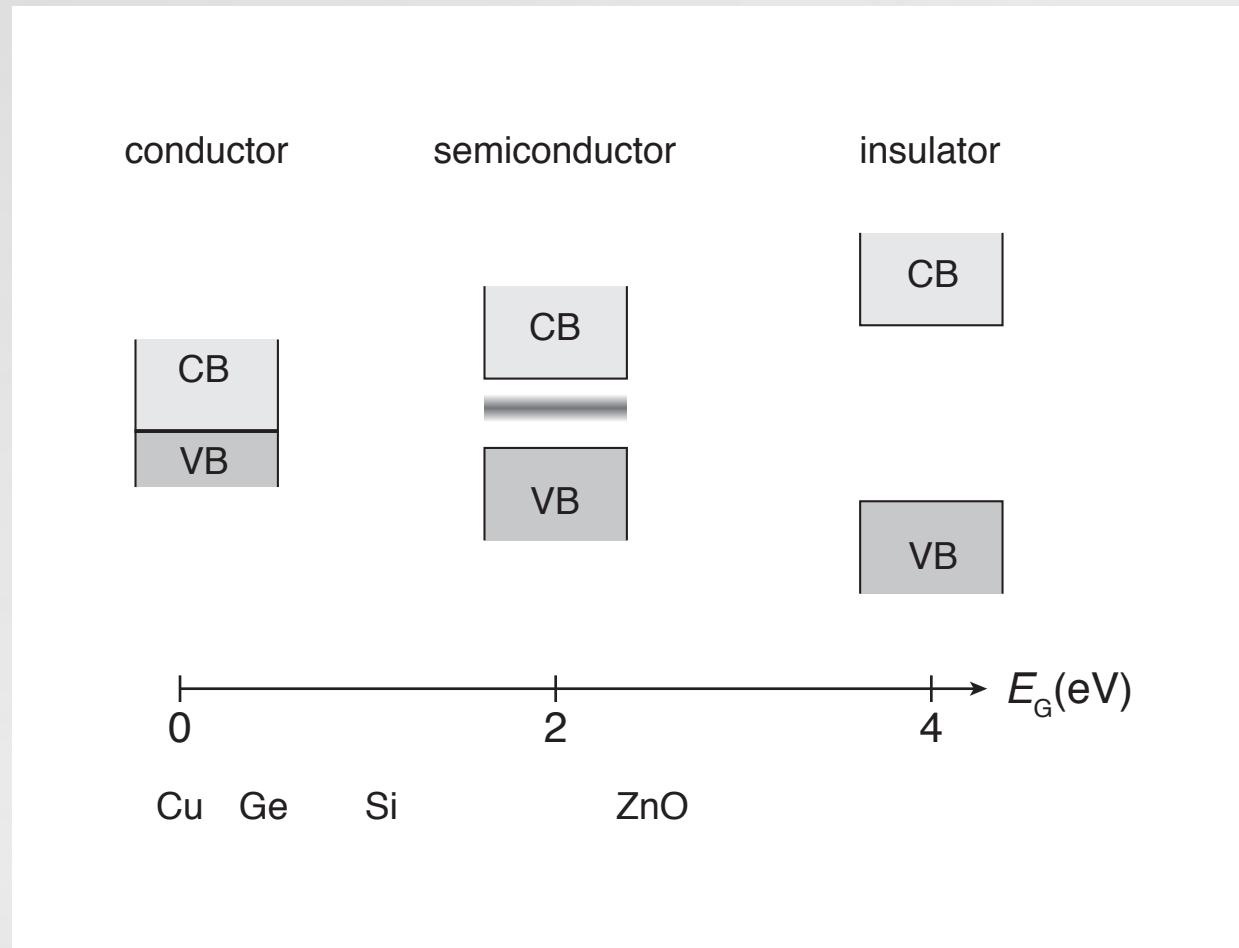
shallow-level dopants control electronic properties

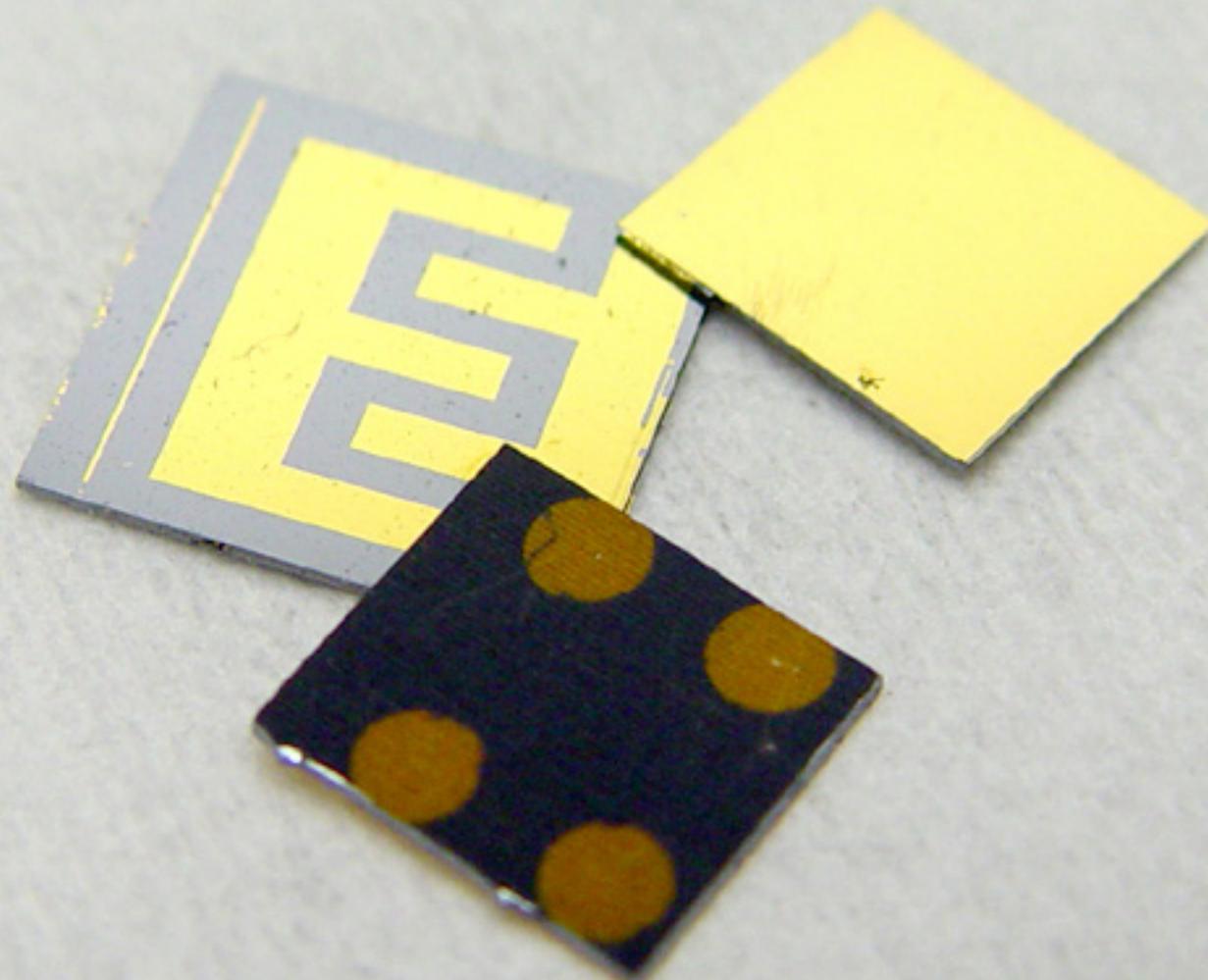


deep-level dopants typically avoided

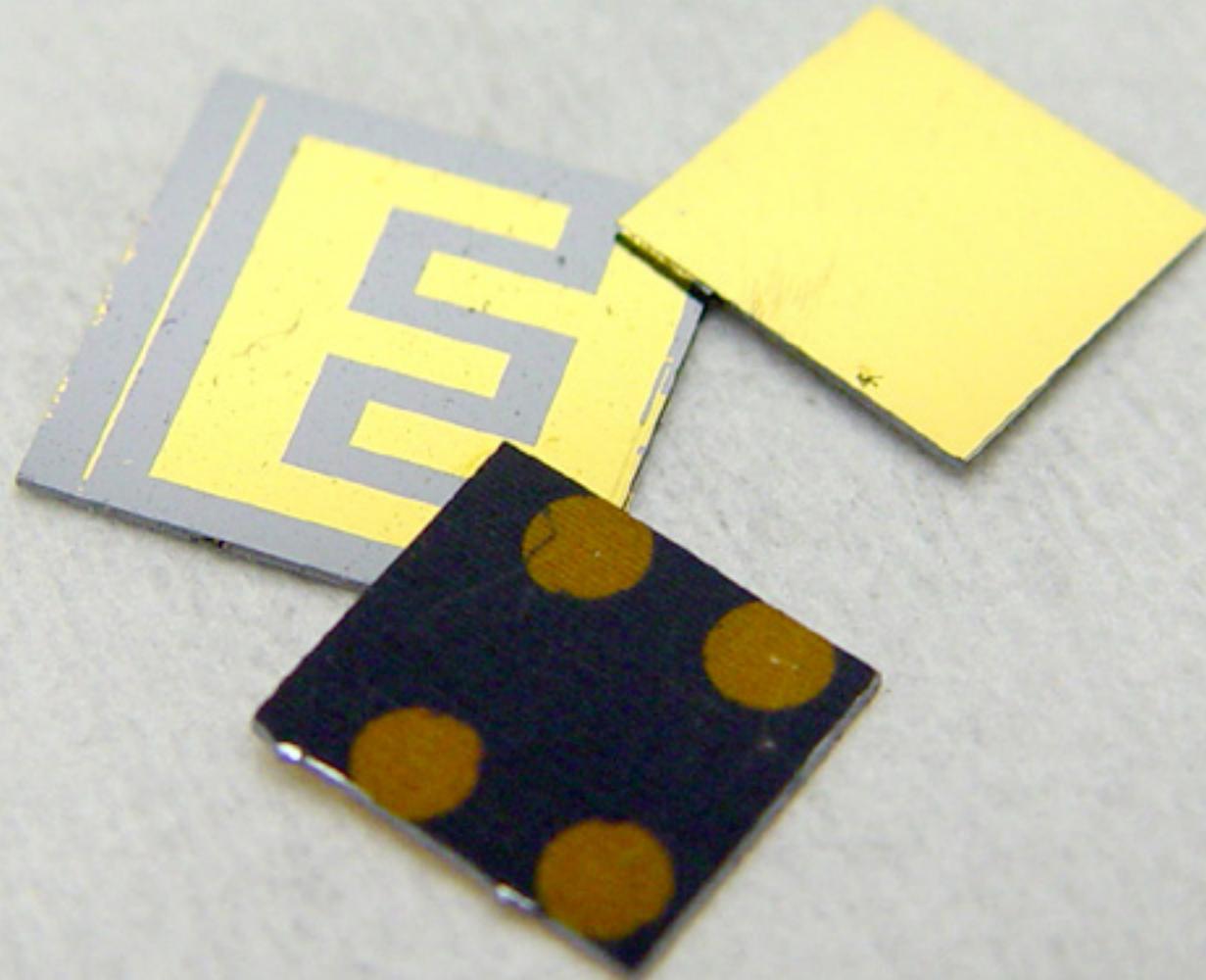


femtosecond laser-doping gives rise to intermediate band



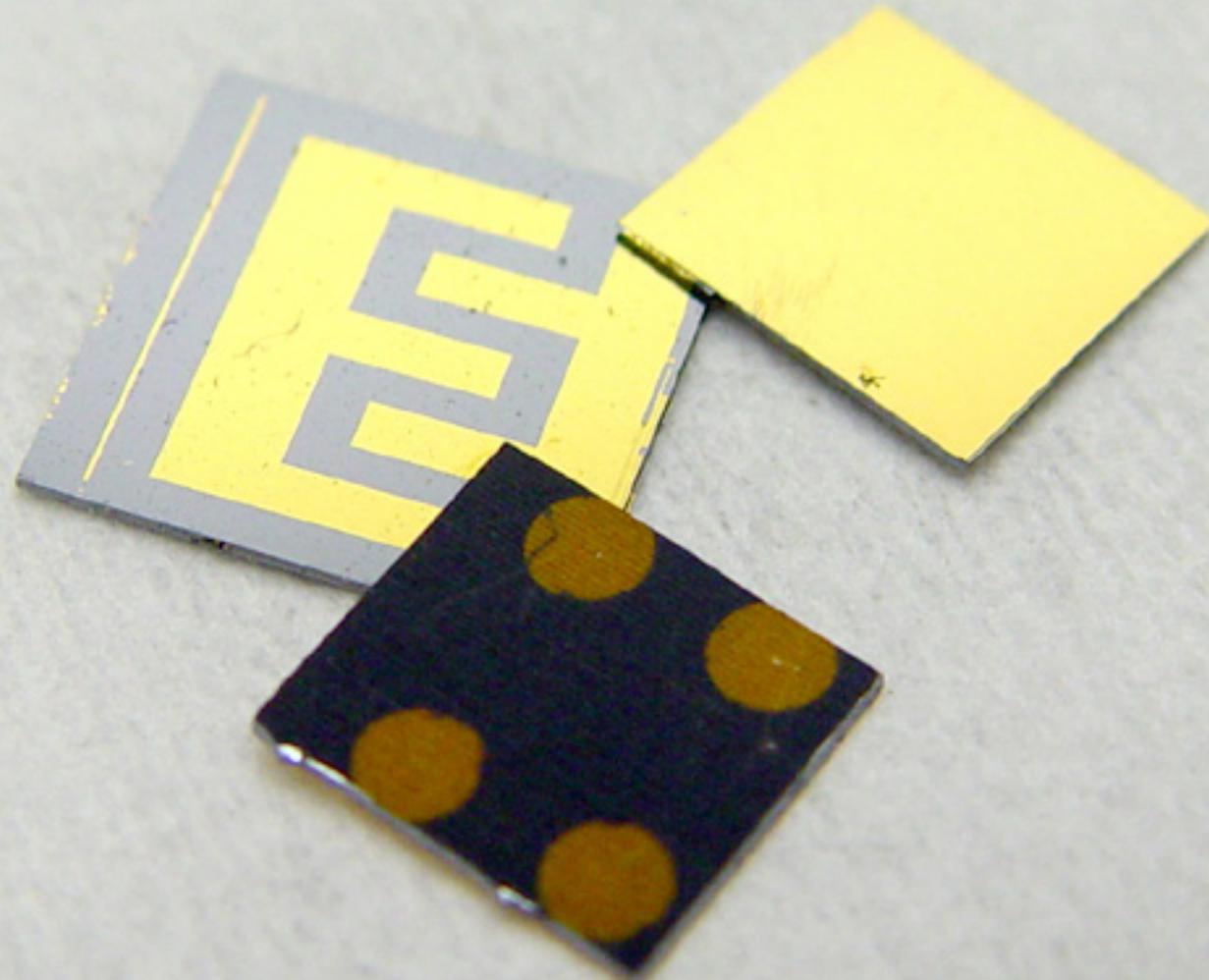


1 intermediate band



1 intermediate band

2 Si devices



1 intermediate band

2 Si devices

3 $\text{X}:\text{TiO}_2$

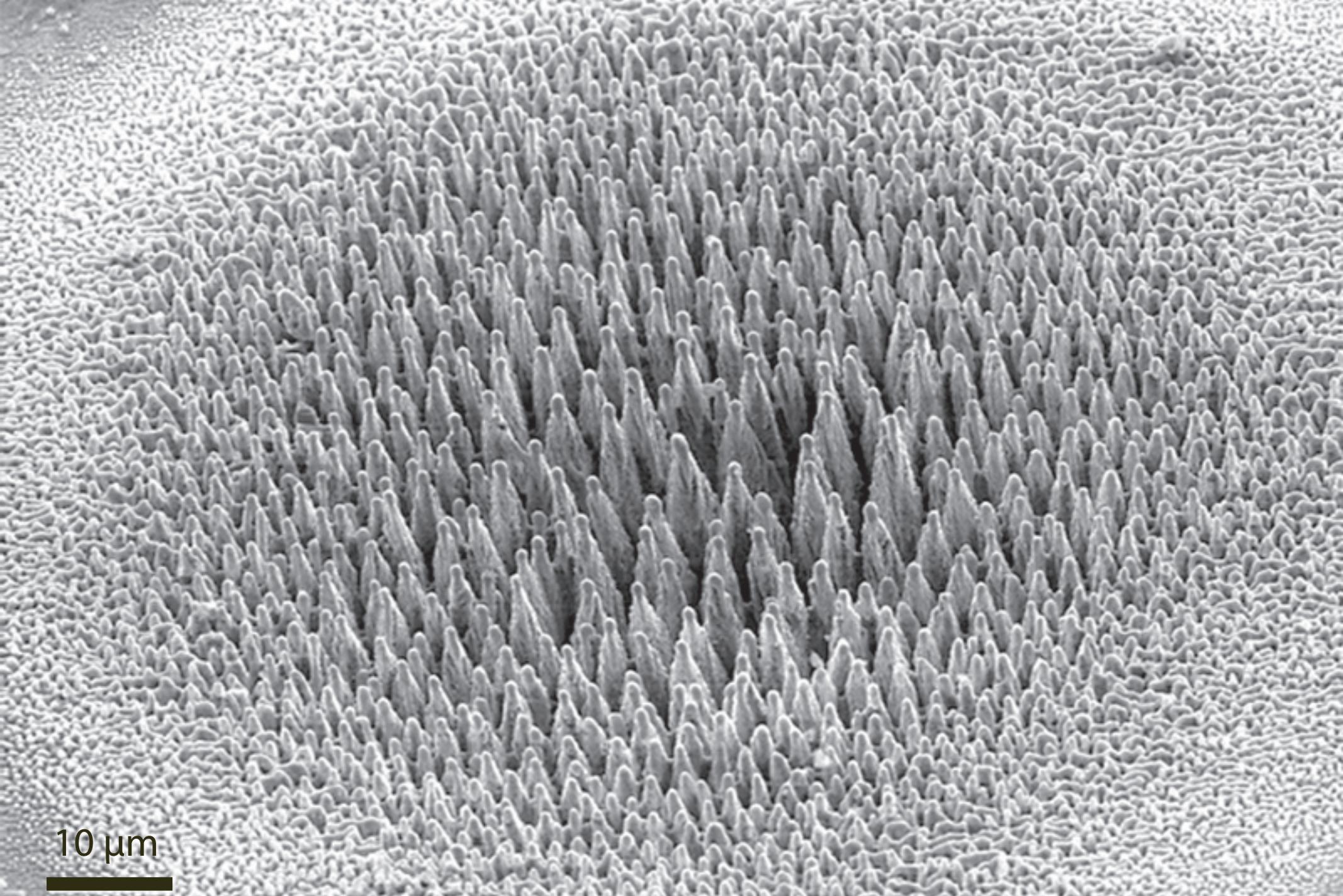
intermediate band formation in chalcogen-hyperdoped Si

dopants:

I															VIII
H															He
Li	Be														
Na	Mg														
K	Ca	Sc	Ti	V	Cr	Mn	Fe	Co	Ni	Cu	Zn	Ga	Ge	As	Se
Rb	Sr	Y	Zr	Nb	Mo	Tc	Ru	Rh	Pd	Ag	Cd	In	Sn	Sb	Te
															I
															Xe

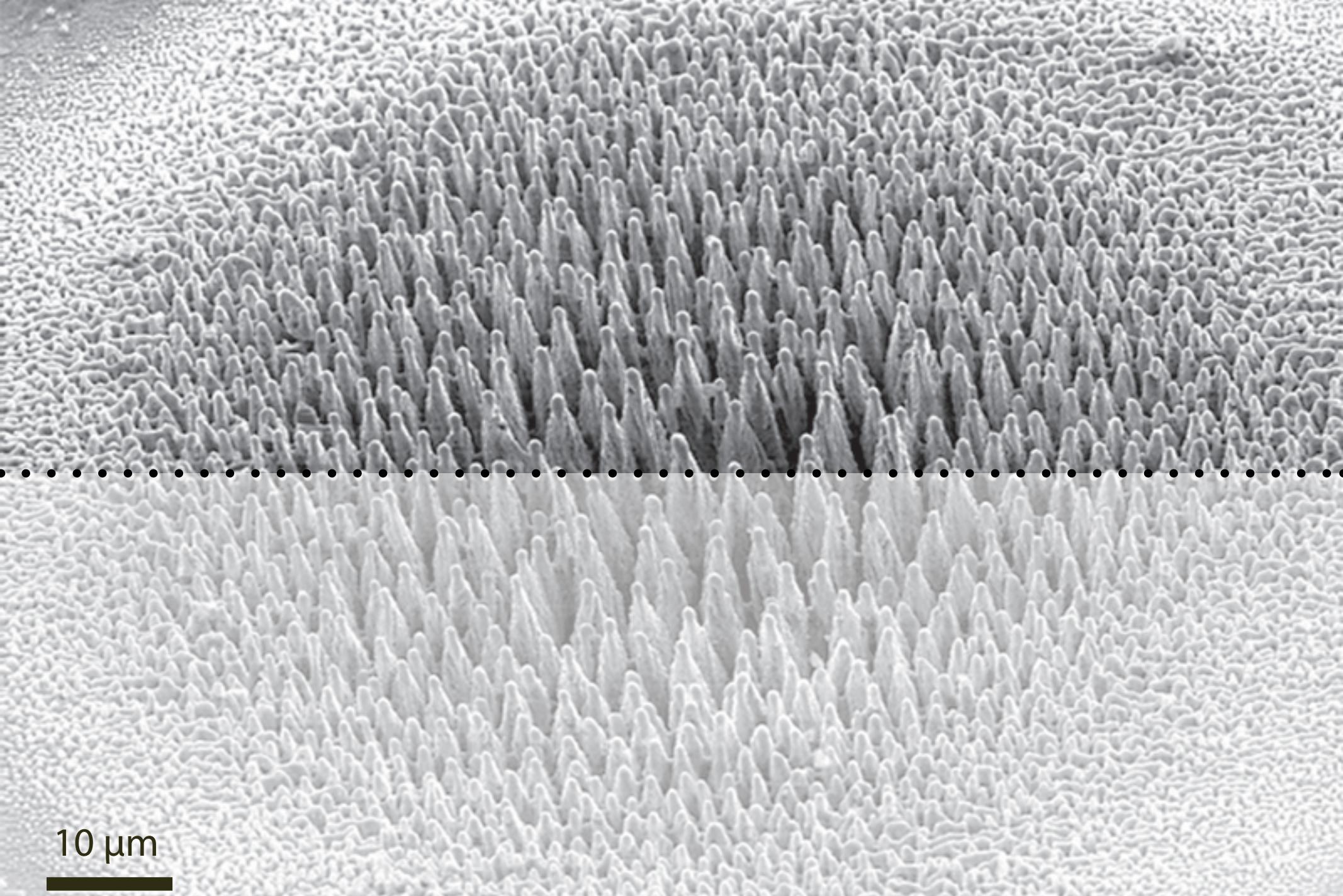
substrates:

Si



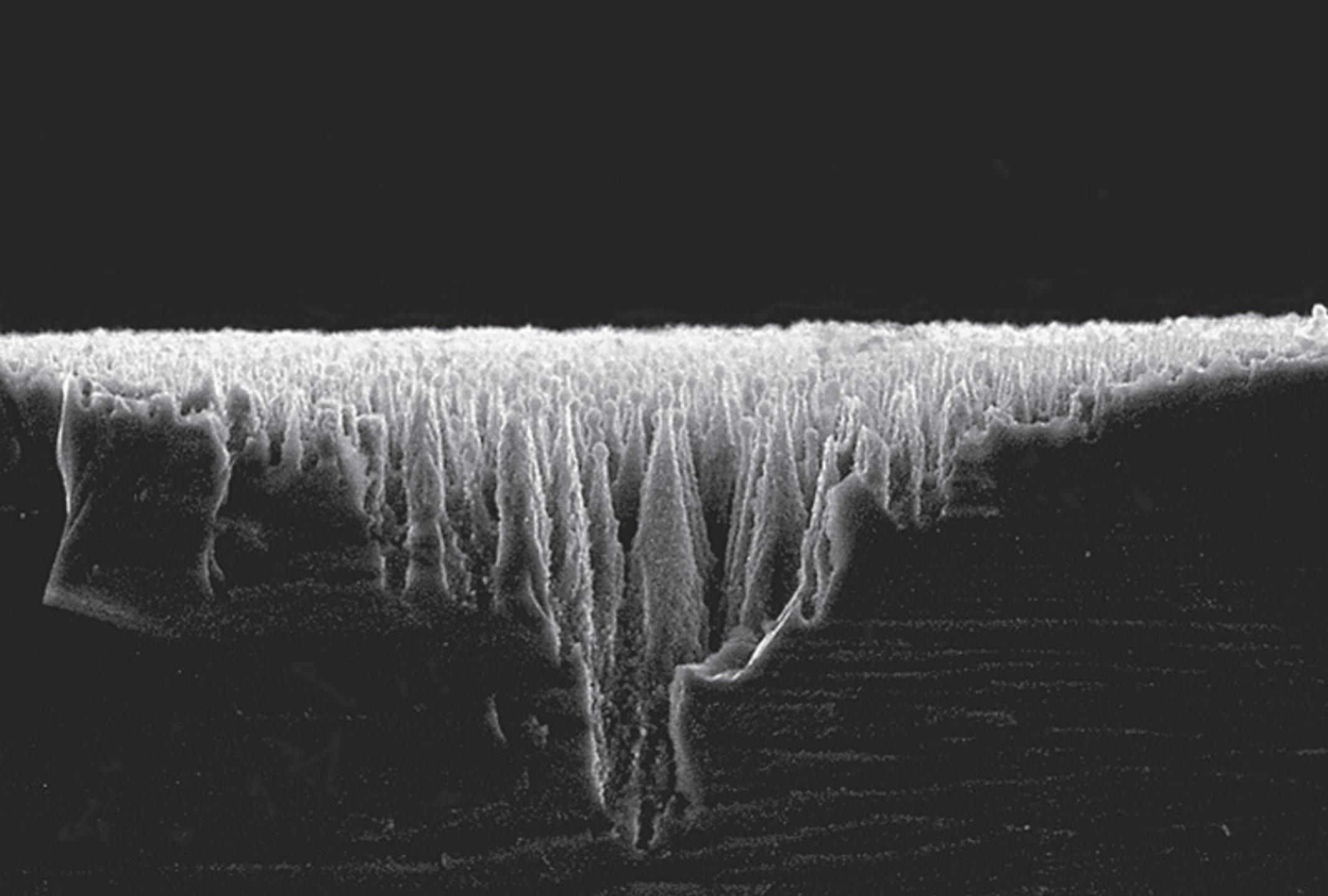
10 µm

1 intermediate band

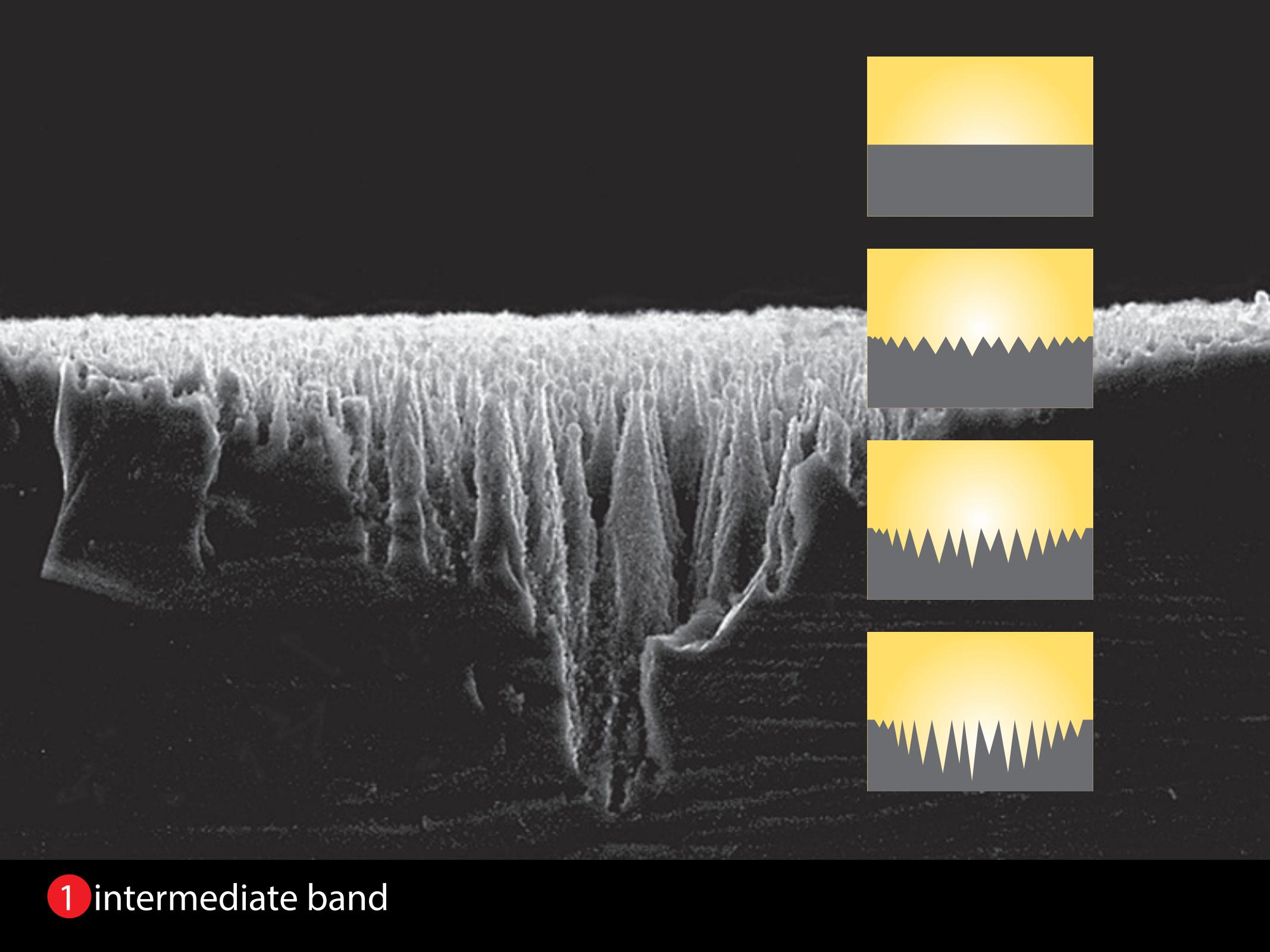


10 µm

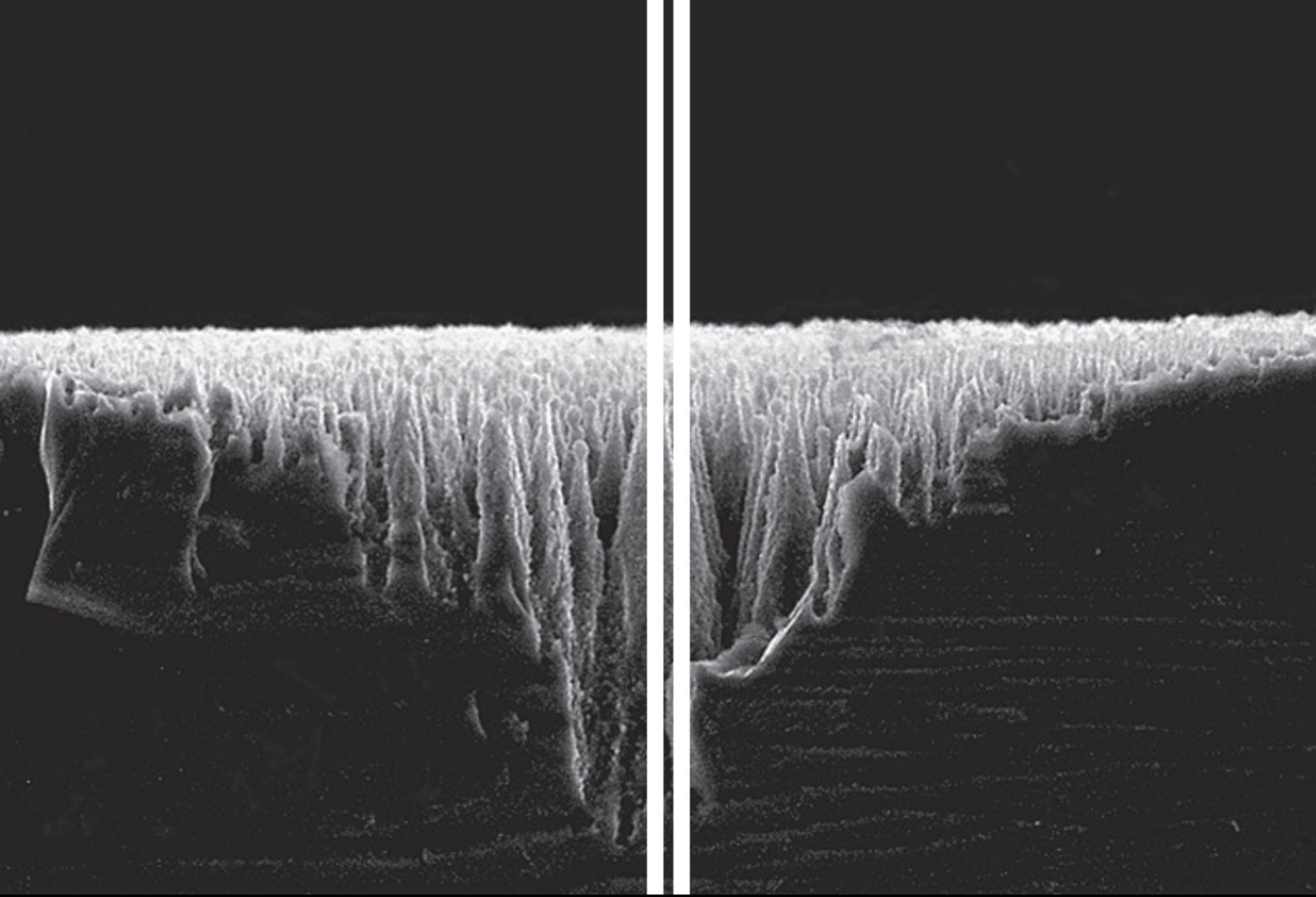
1 intermediate band



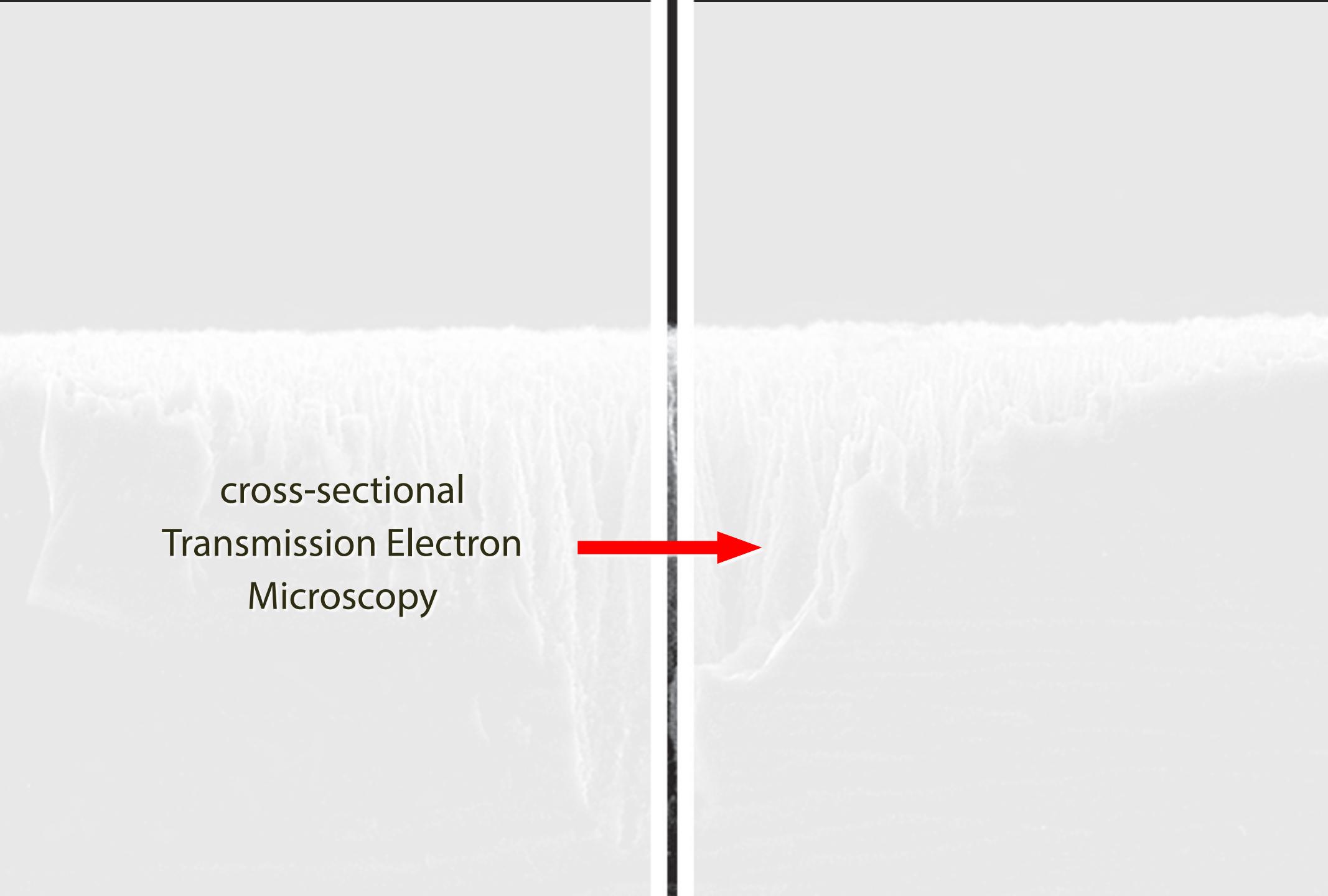
1 intermediate band



1 intermediate band



1 intermediate band

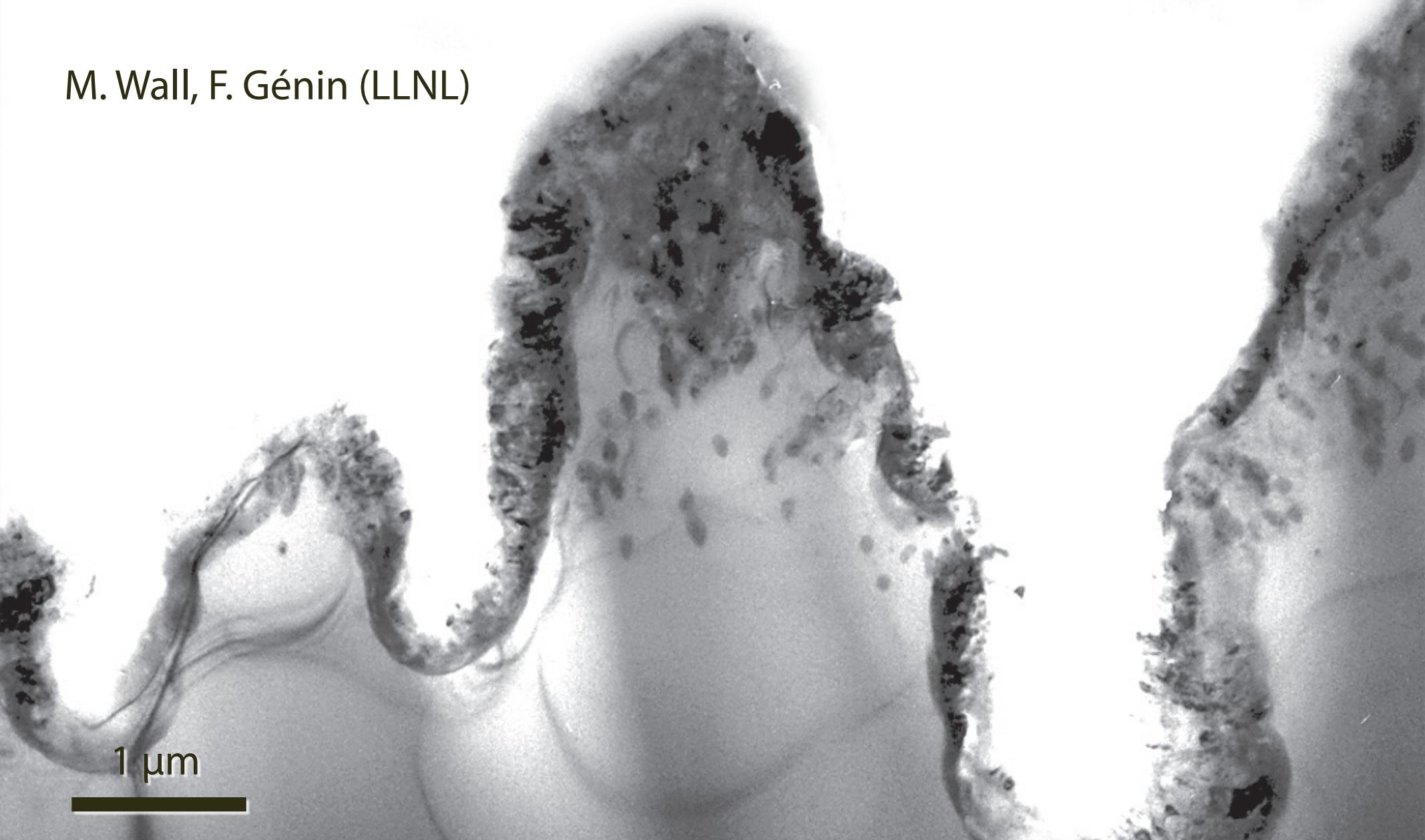


cross-sectional
Transmission Electron
Microscopy



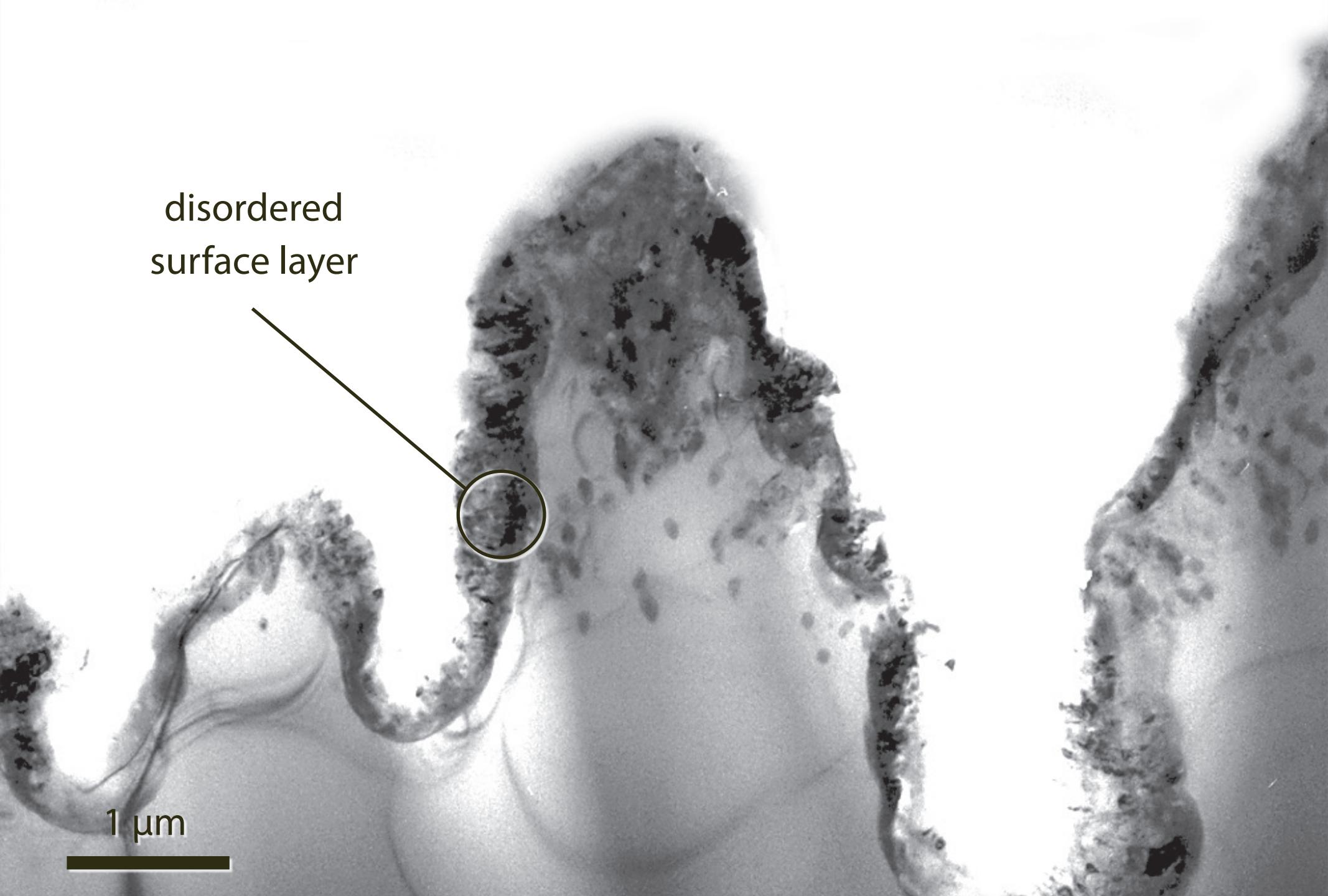
1 intermediate band

M. Wall, F. Génin (LLNL)



1 μ m

1 intermediate band



disordered
surface layer

1 μm

1 intermediate band

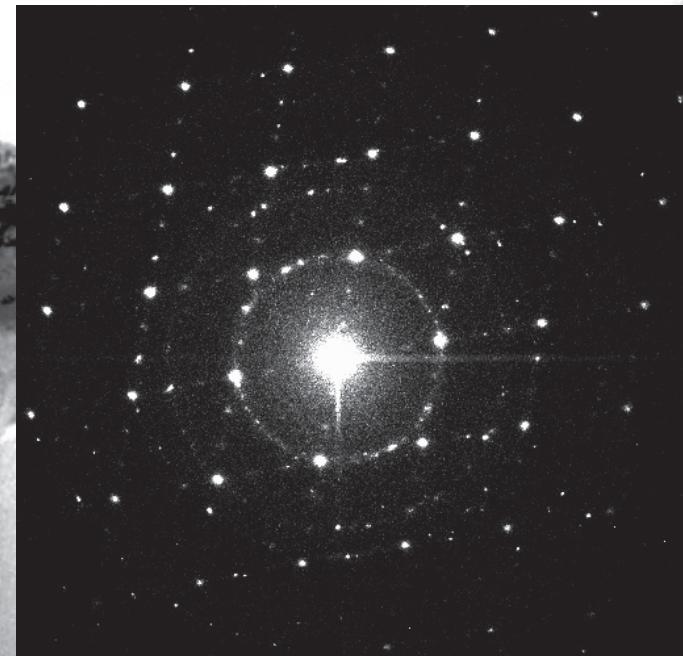


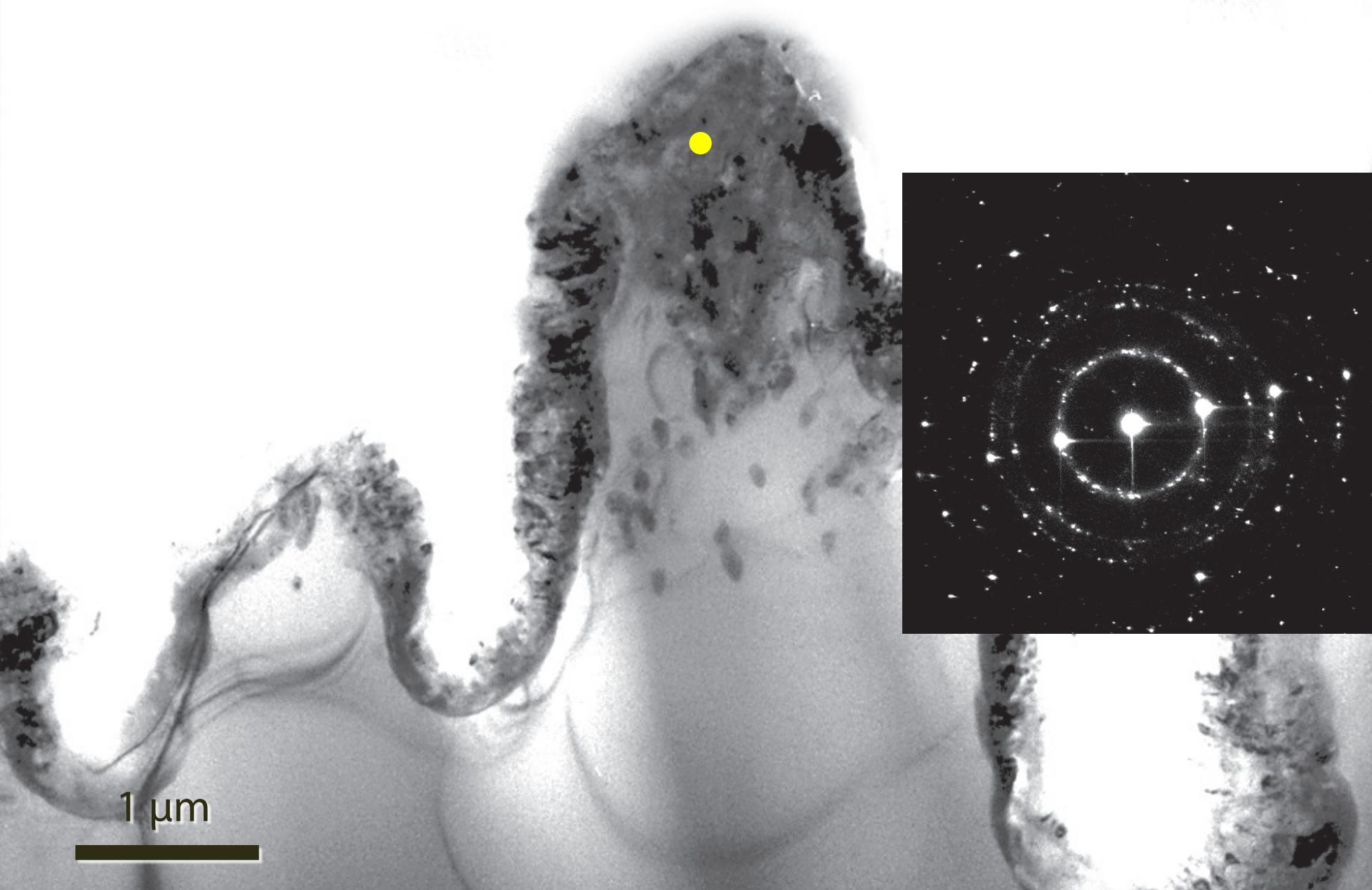
1 μm

electron
diffraction



1 intermediate band





1 μm

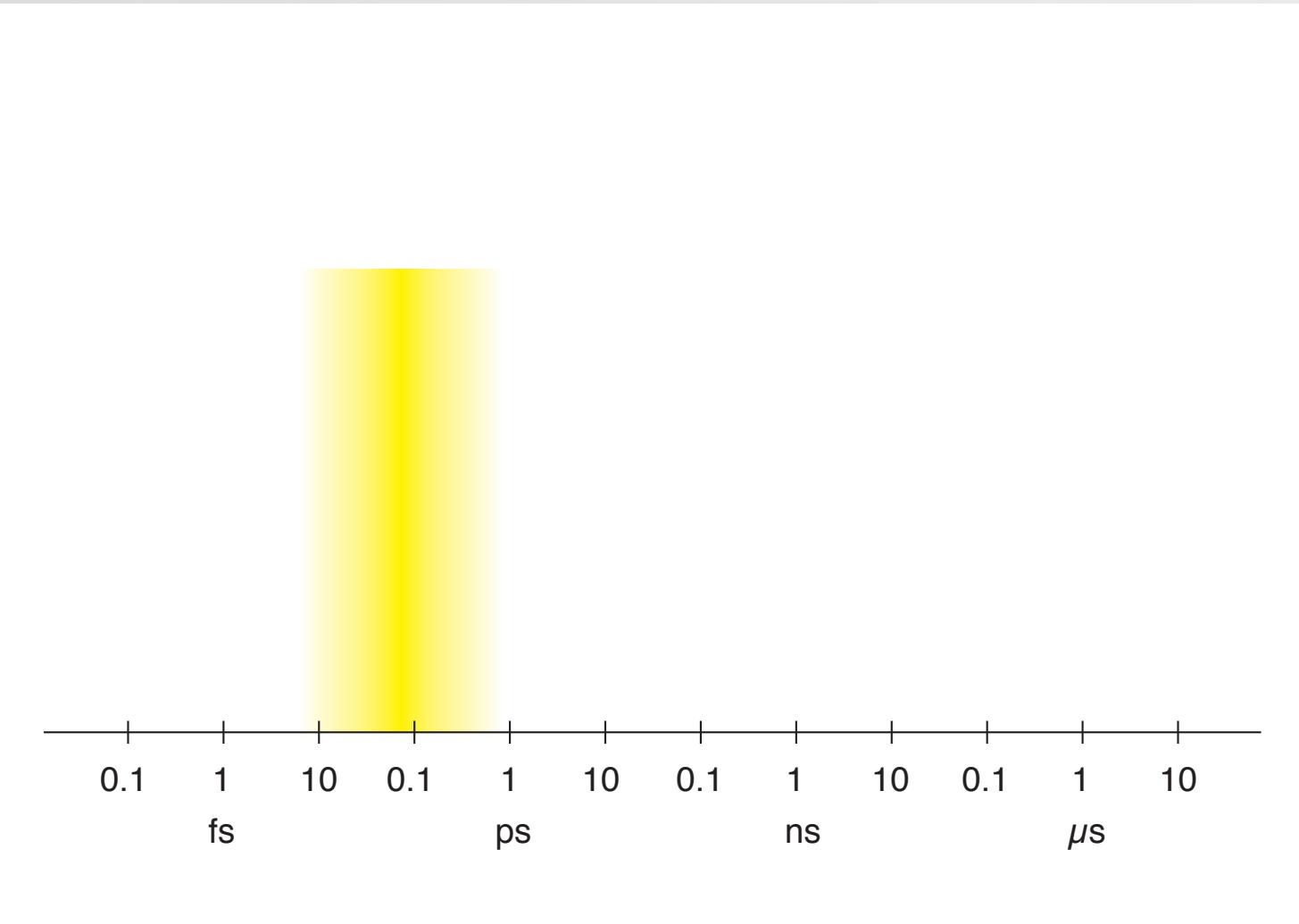
1 intermediate band

- 300-nm disordered surface layer
- undisturbed crystalline core
- surface layer: polycrystalline Si with 1.6% sulfur

1 μm

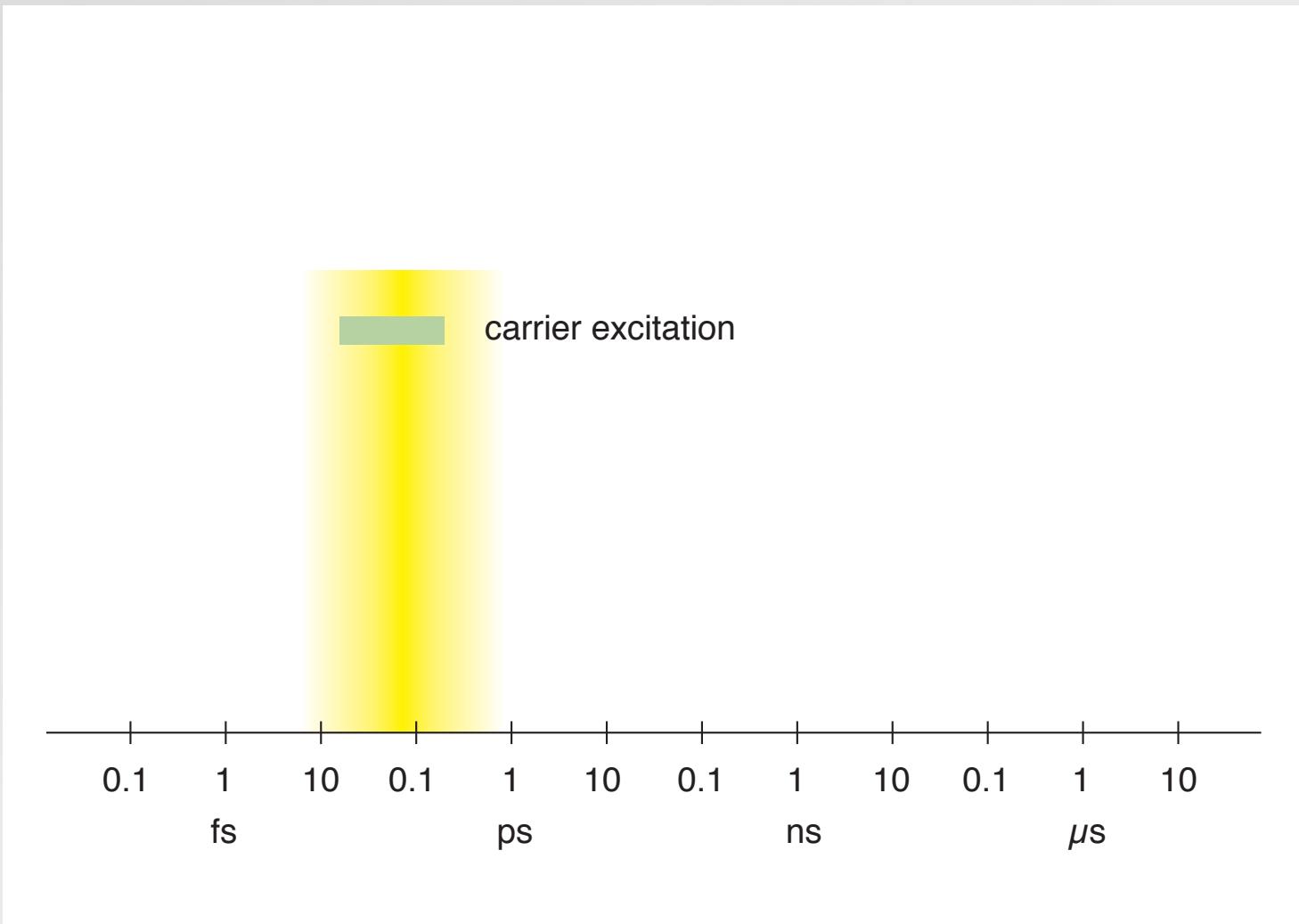
1 intermediate band

relevant time scales

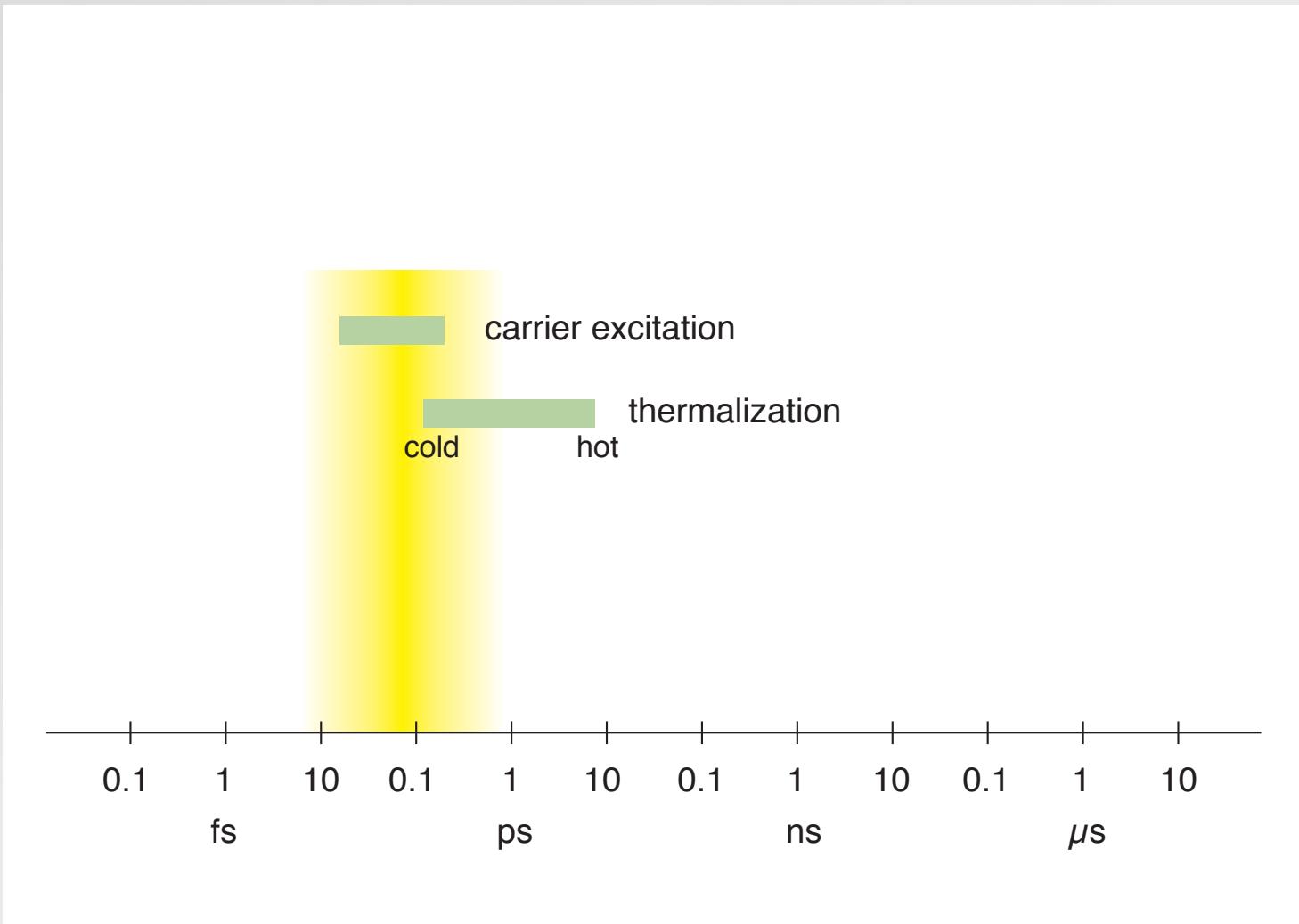


1 intermediate band

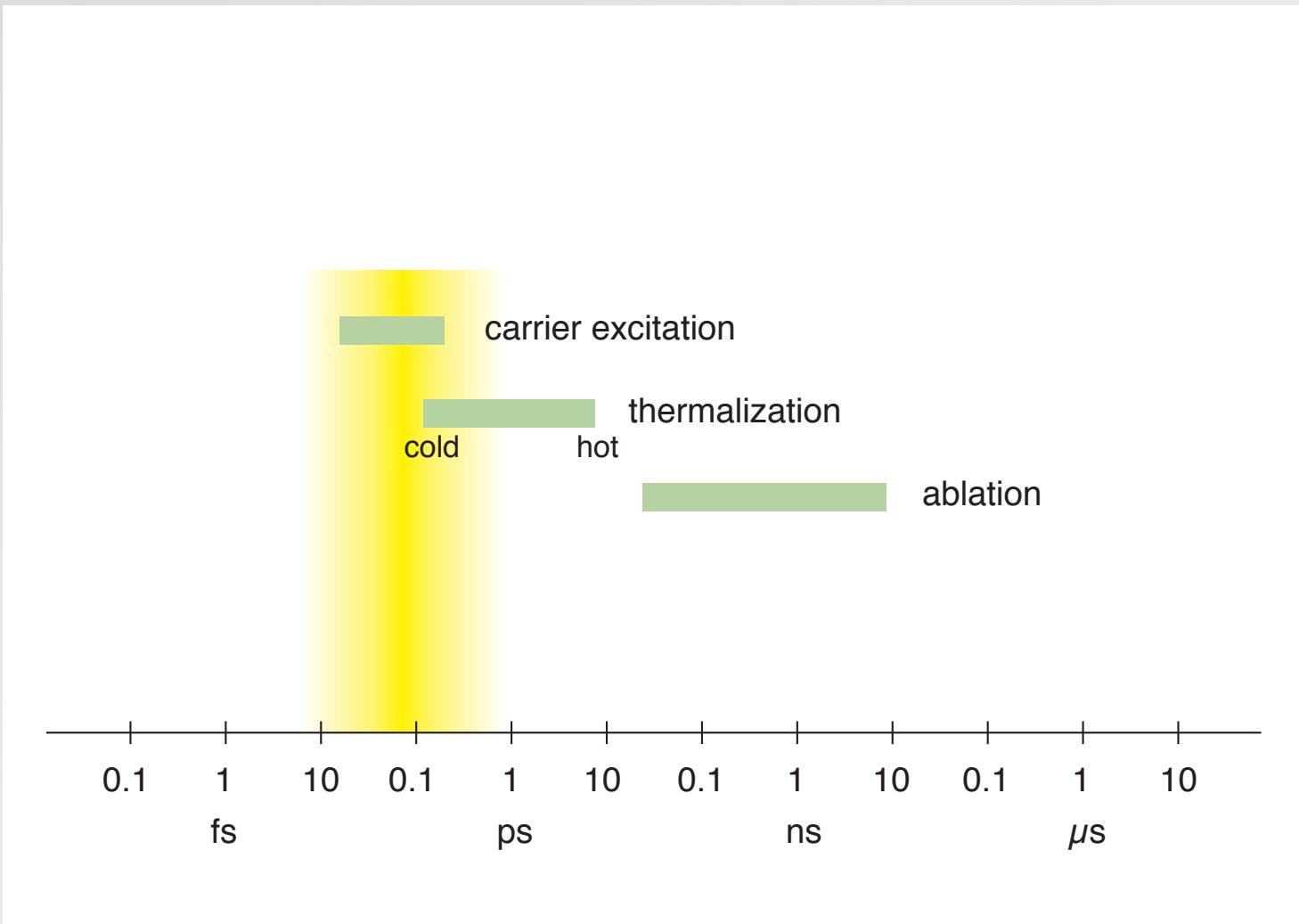
relevant time scales



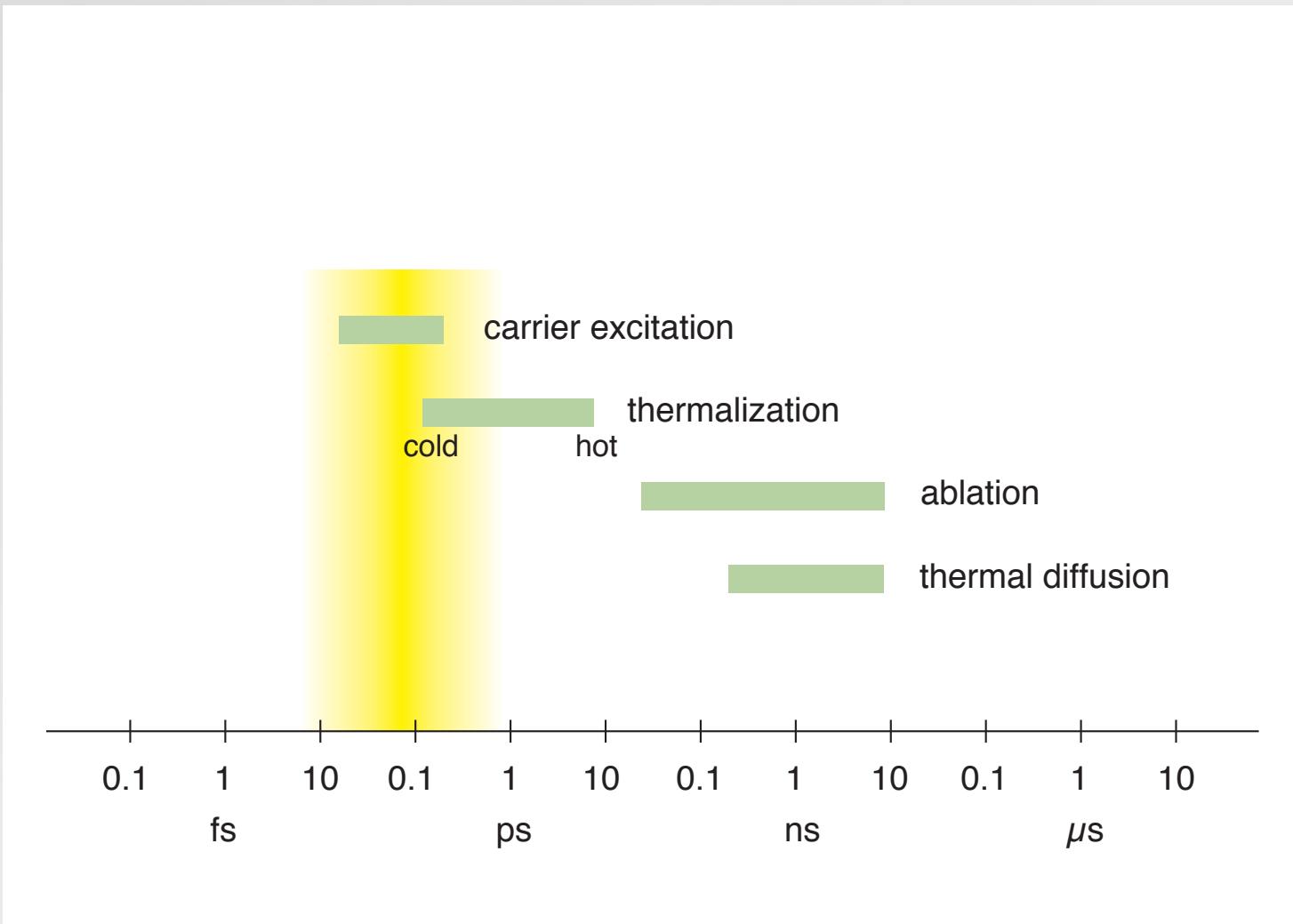
relevant time scales



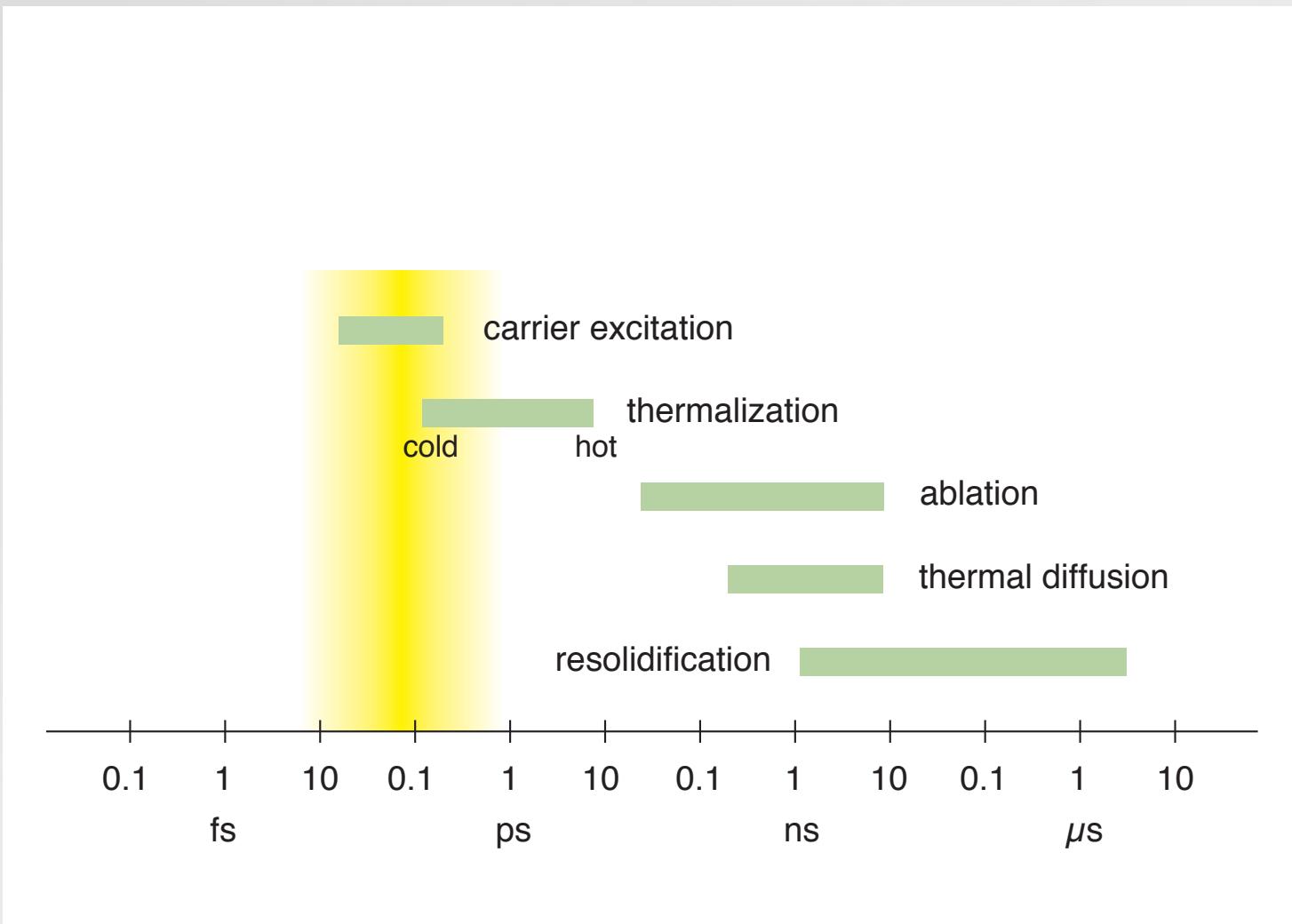
relevant time scales



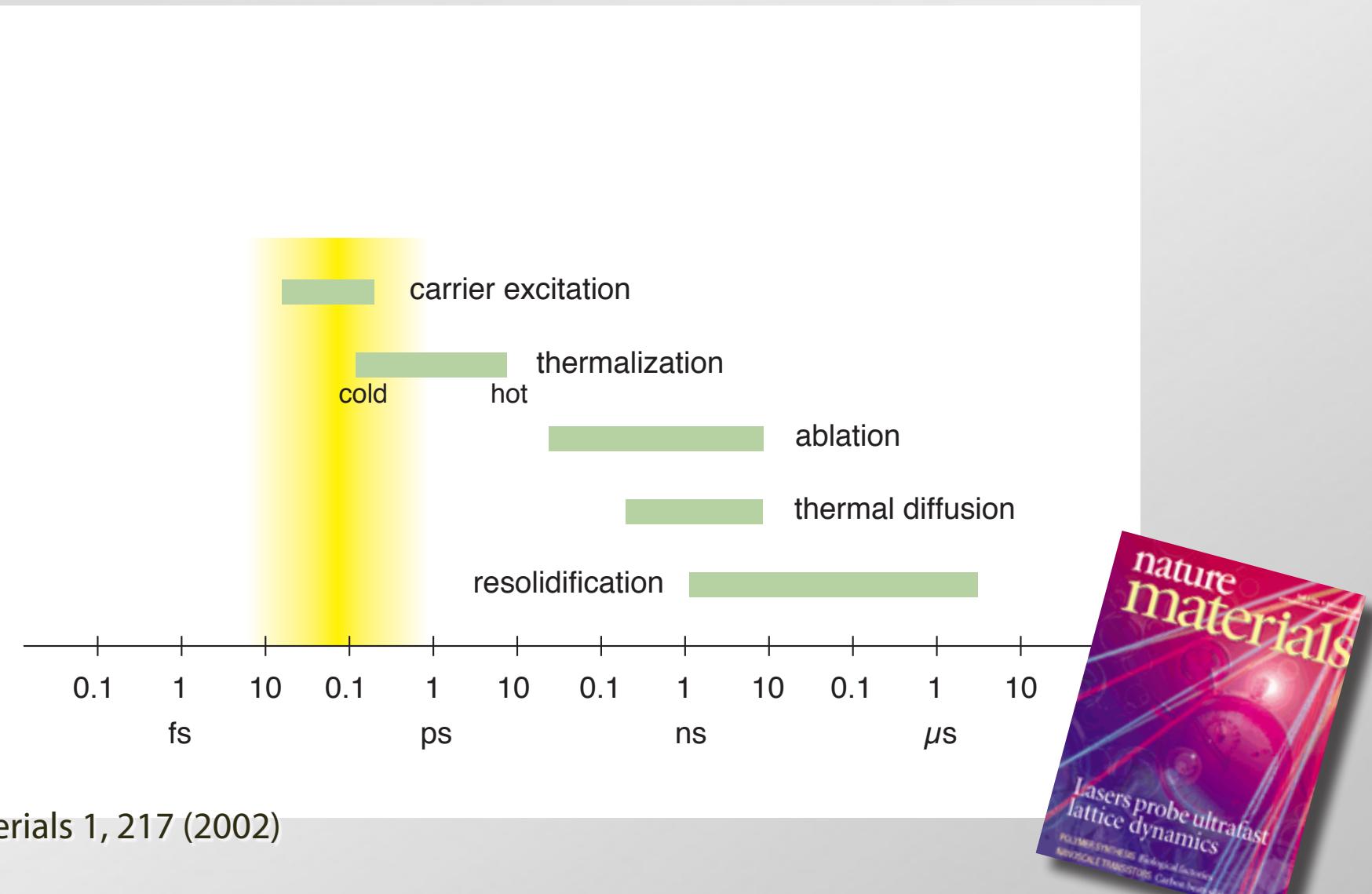
relevant time scales



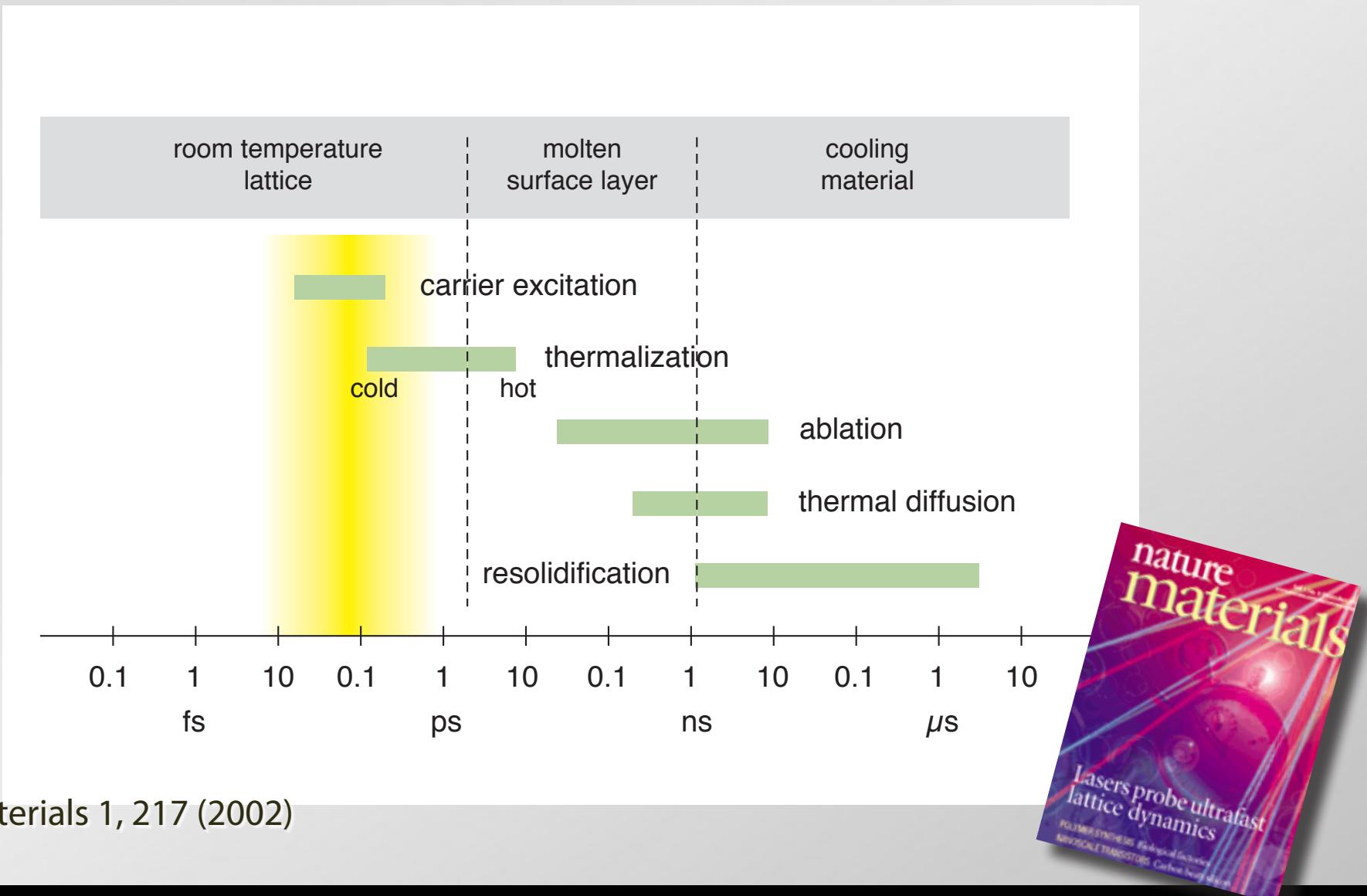
relevant time scales



relevant time scales



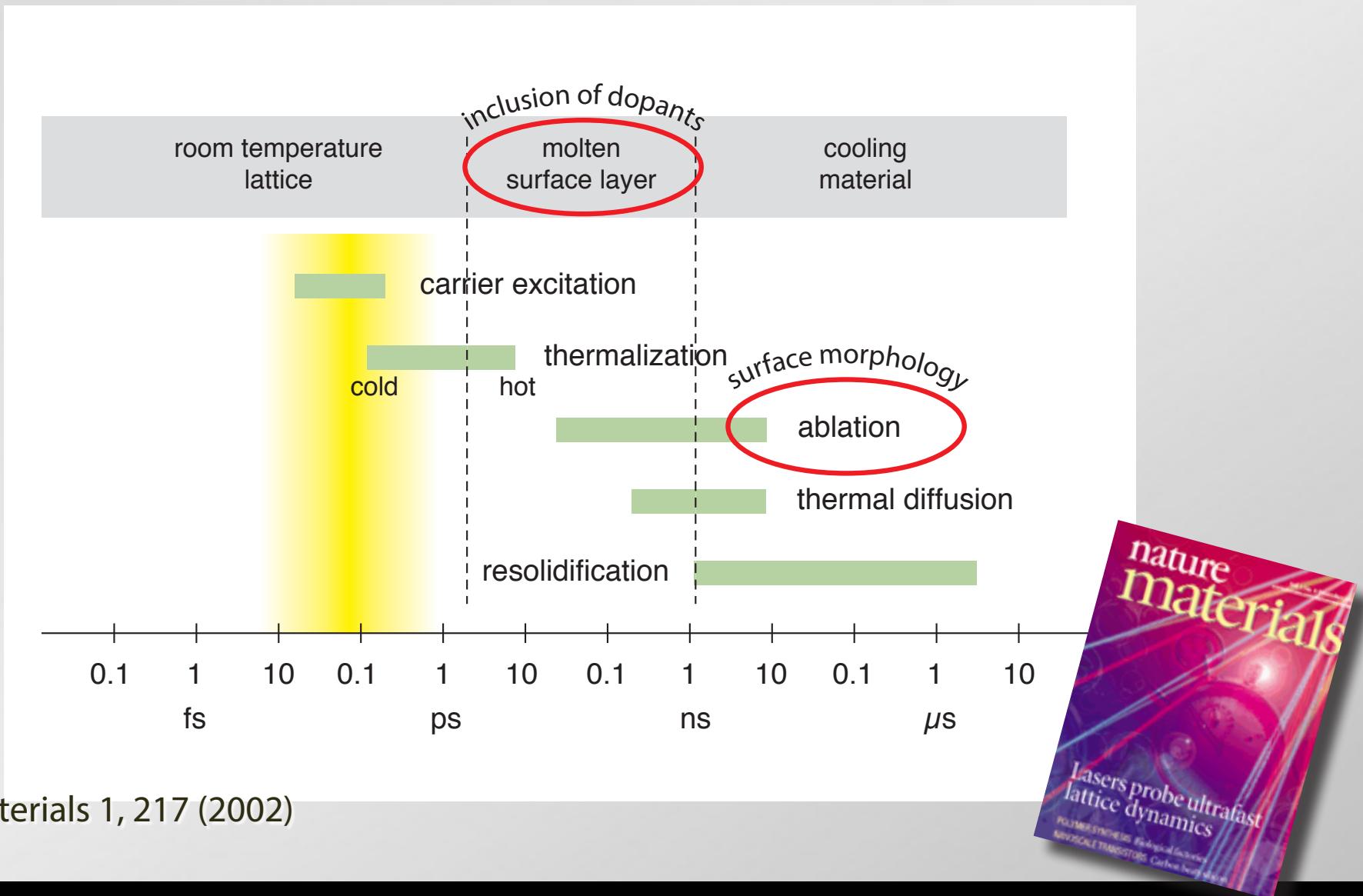
relevant time scales



Nature Materials 1, 217 (2002)



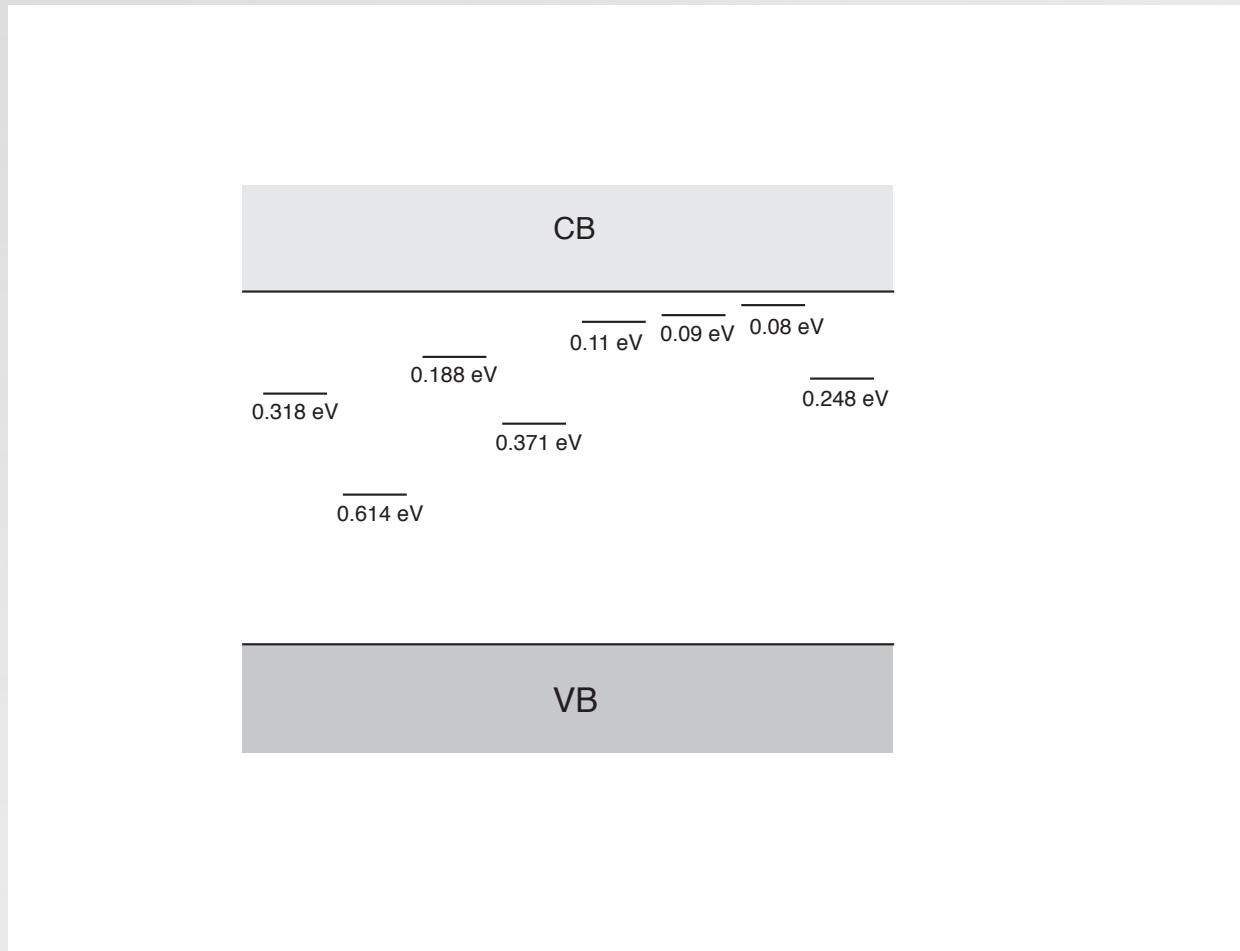
relevant time scales



Nature Materials 1, 217 (2002)

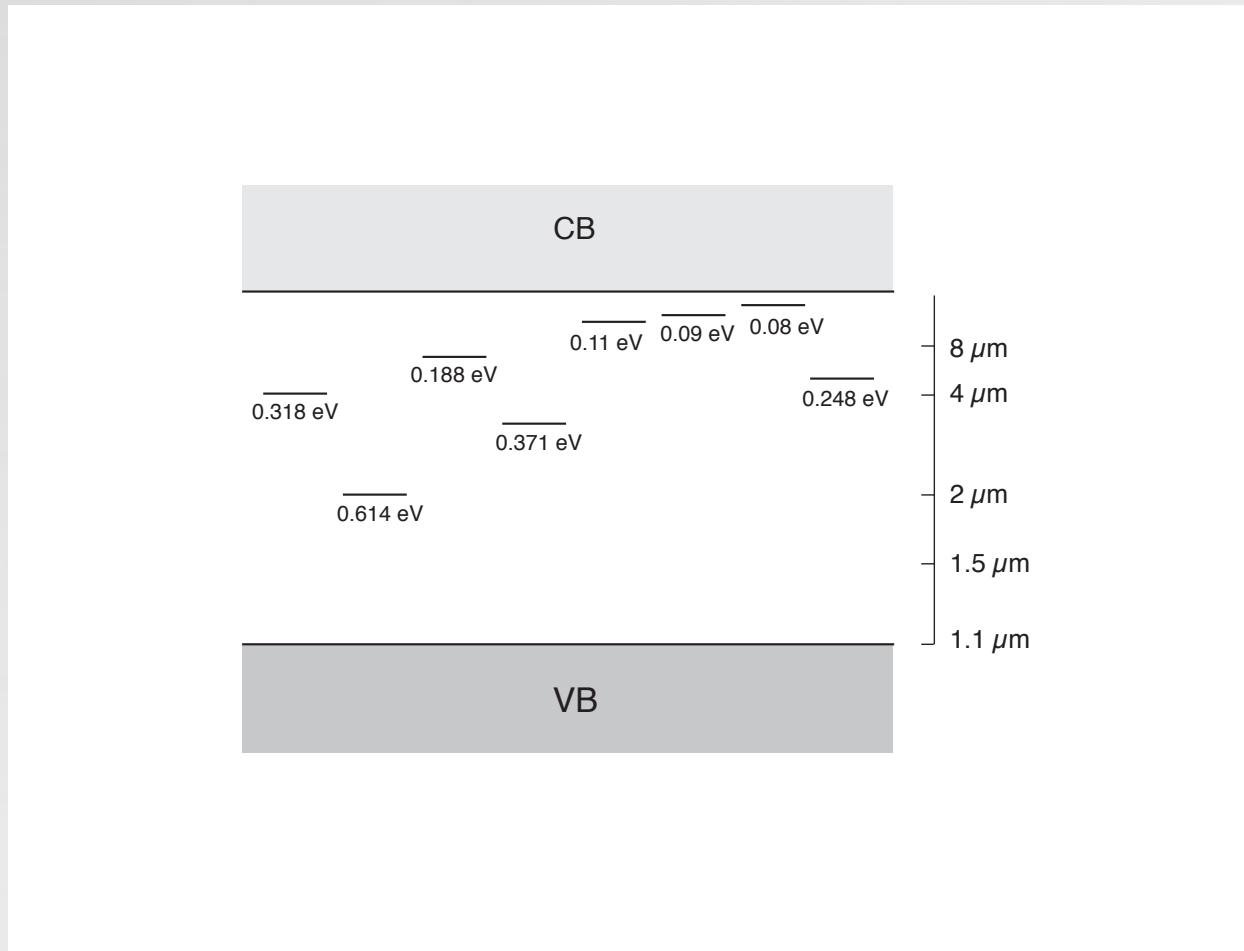


1 part in 10^6 sulfur introduces donor states in gap



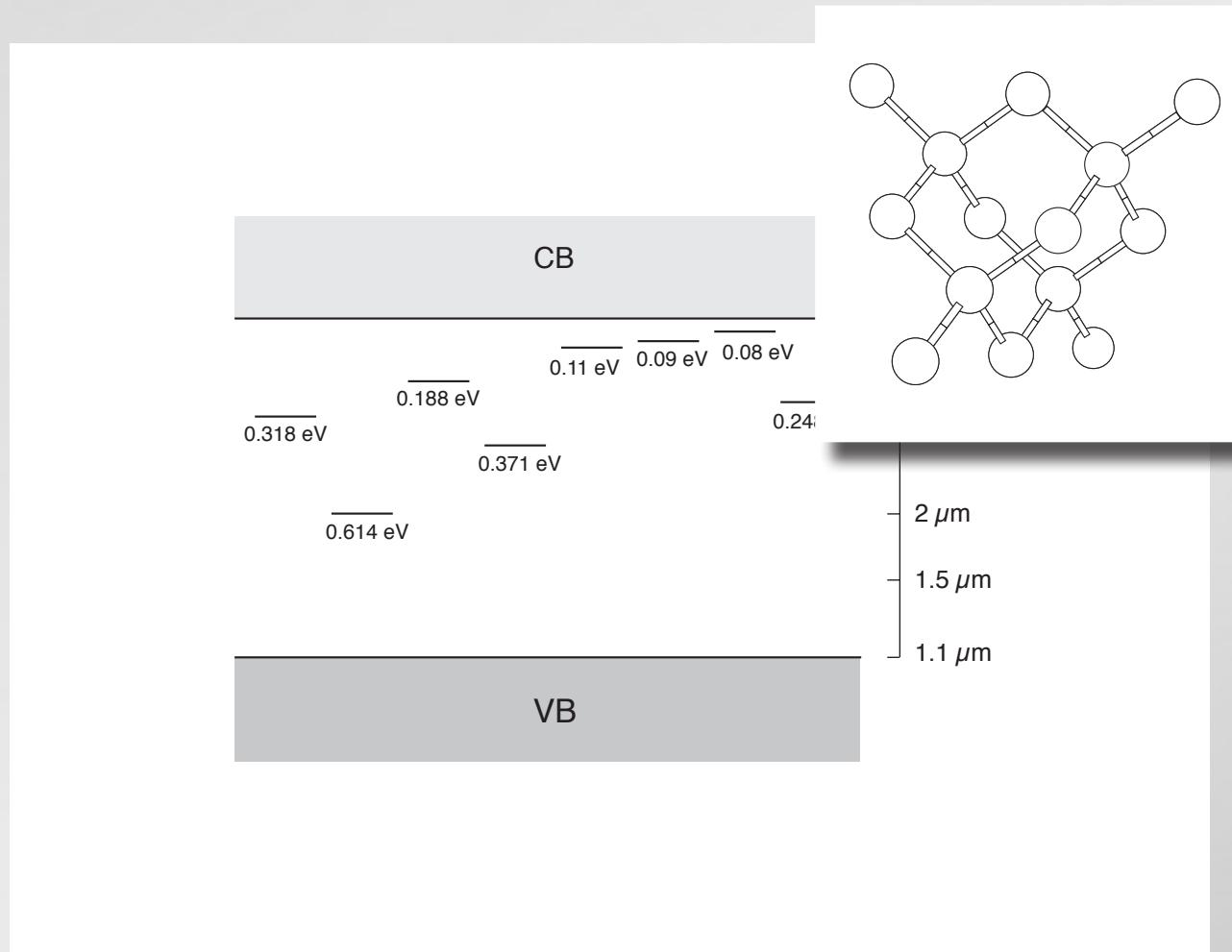
Janzén et al., Phys. Rev. B 29, 1907 (1984)

1 part in 10^6 sulfur introduces donor states in gap



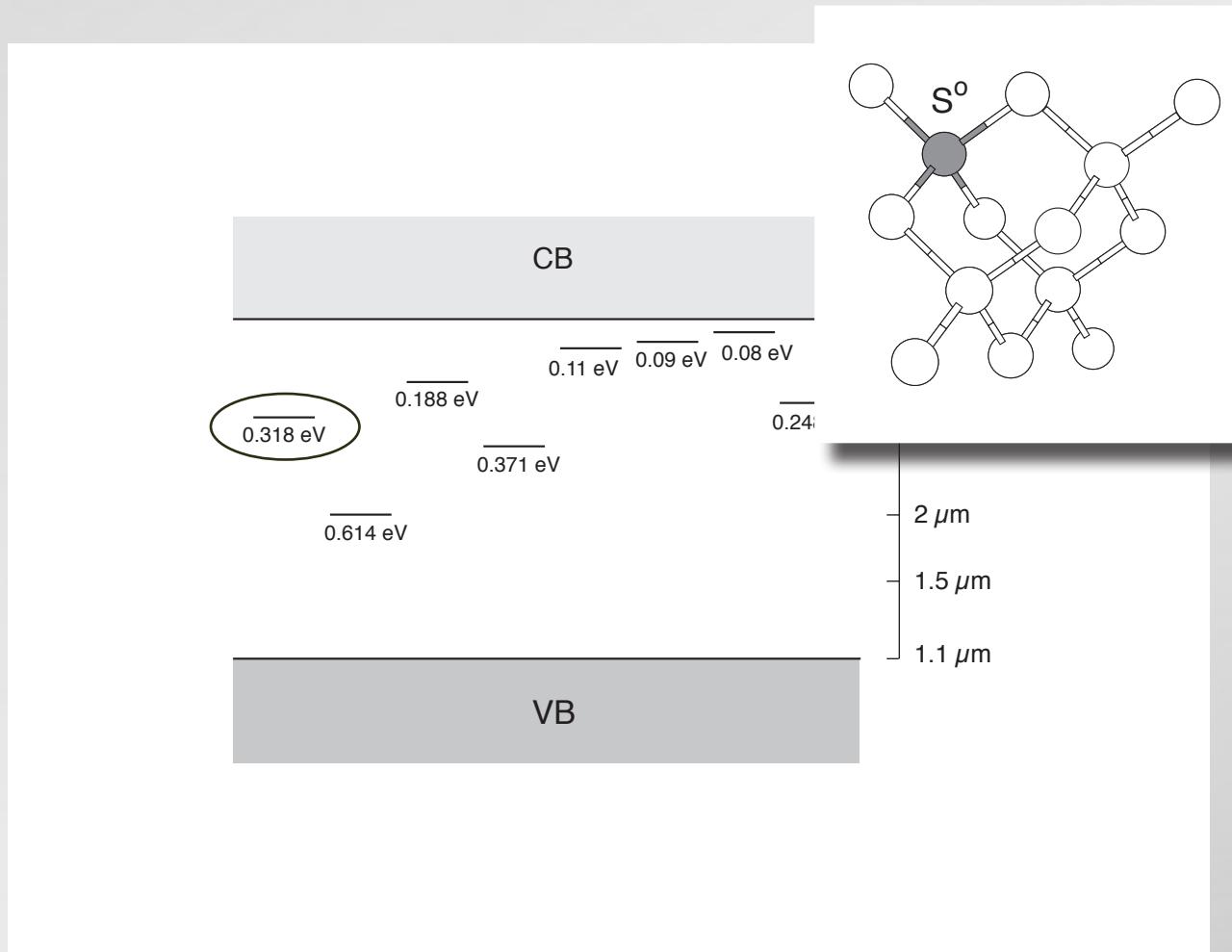
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1 part in 10^6 sulfur introduces donor states in gap



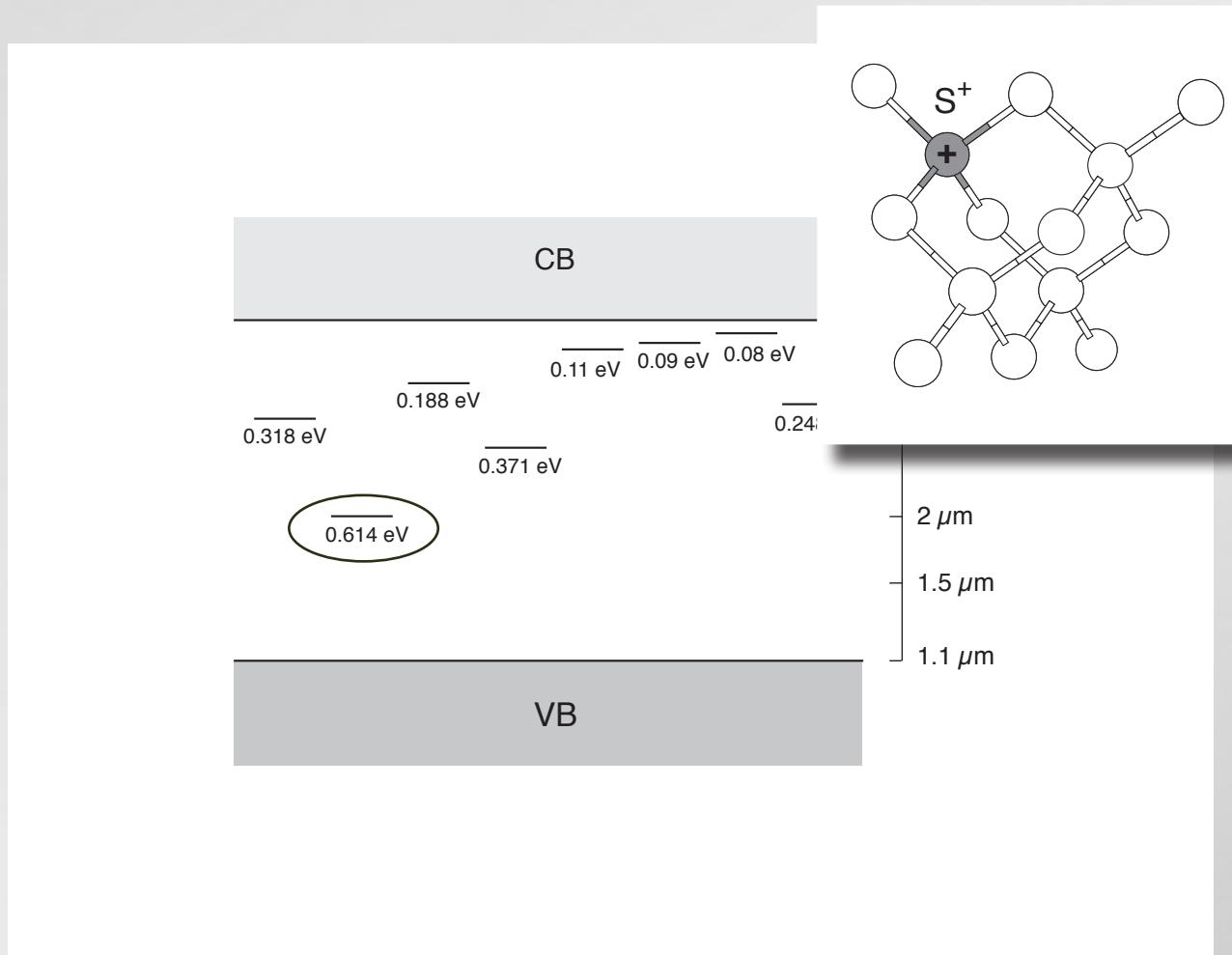
Janzén et al., Phys. Rev. B 29, 1907 (1984)

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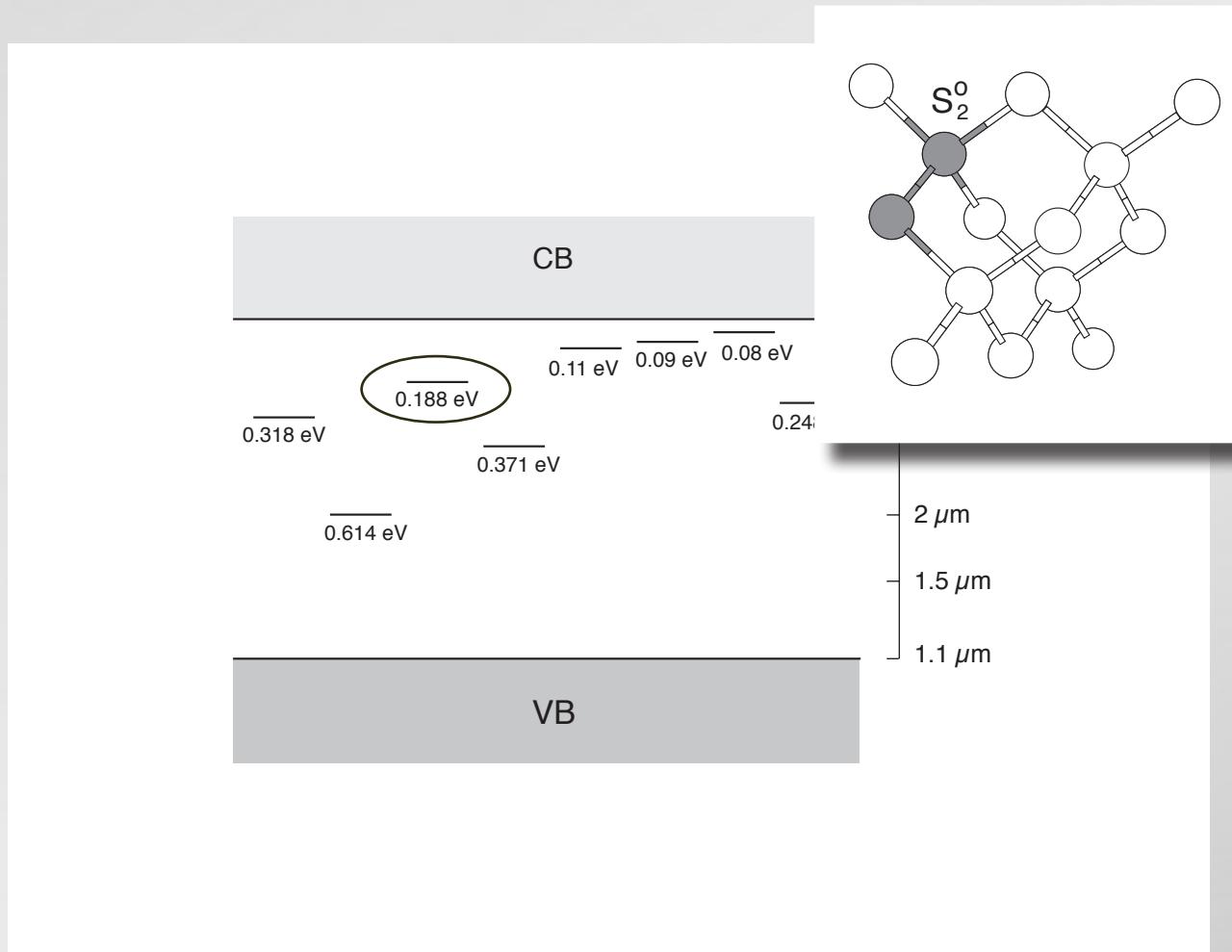
Janzén et al., Phys. Rev. B 29, 1907 (1984)

1 part in 10^6 sulfur introduces donor states in gap



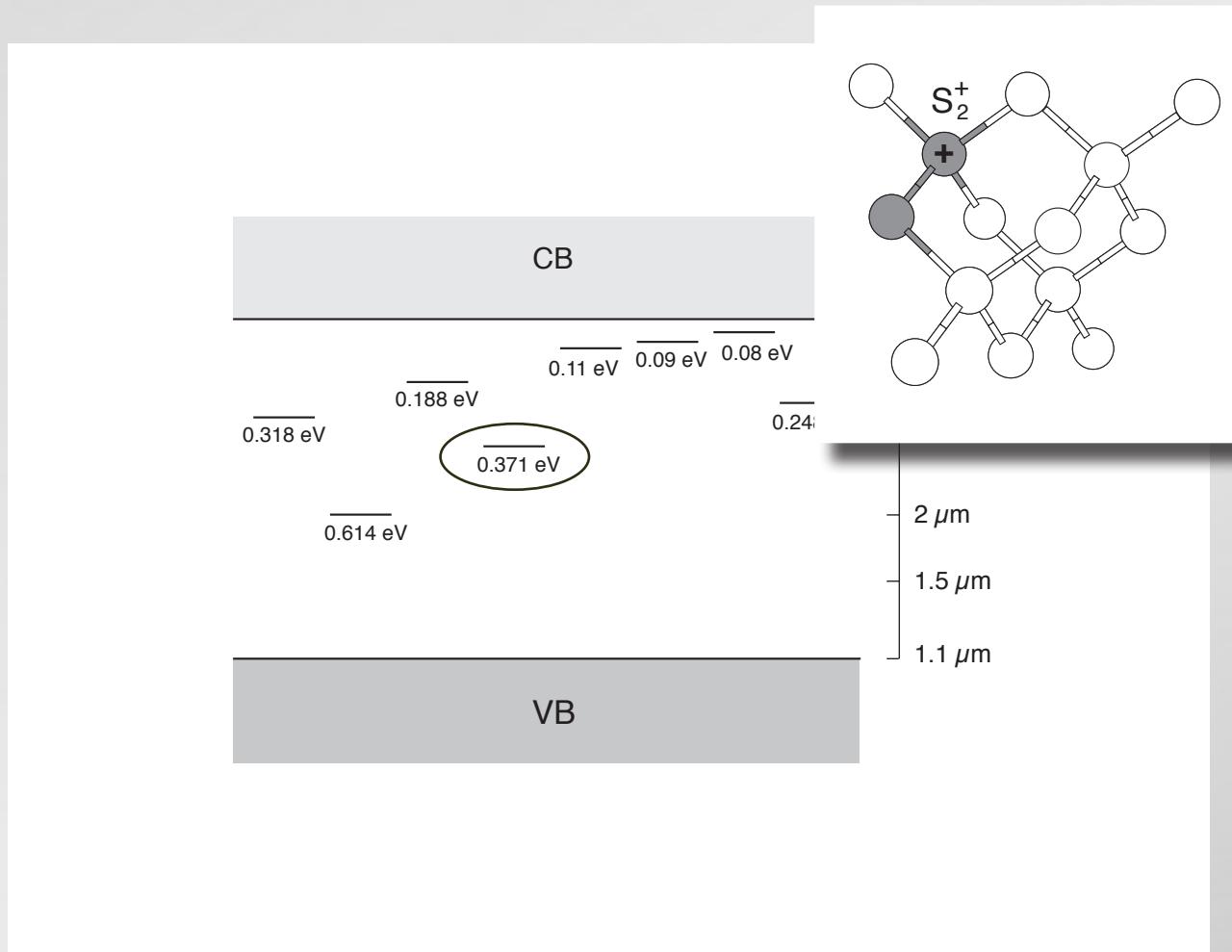
Janzén et al., Phys. Rev. B 29, 1907 (1984)

1 part in 10^6 sulfur introduces donor states in gap



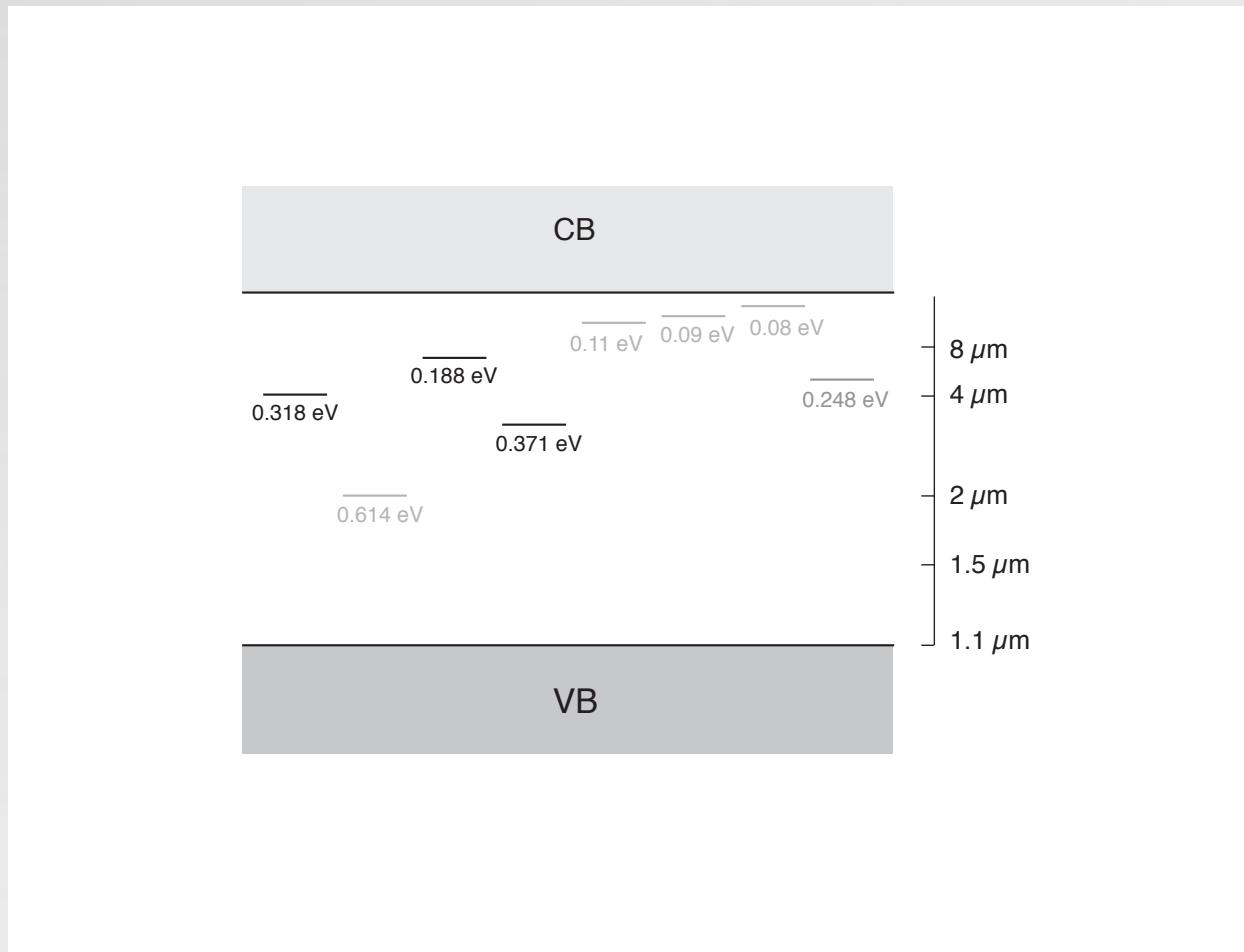
Janzén et al., Phys. Rev. B 29, 1907 (1984)

1 part in 10^6 sulfur introduces donor states in gap



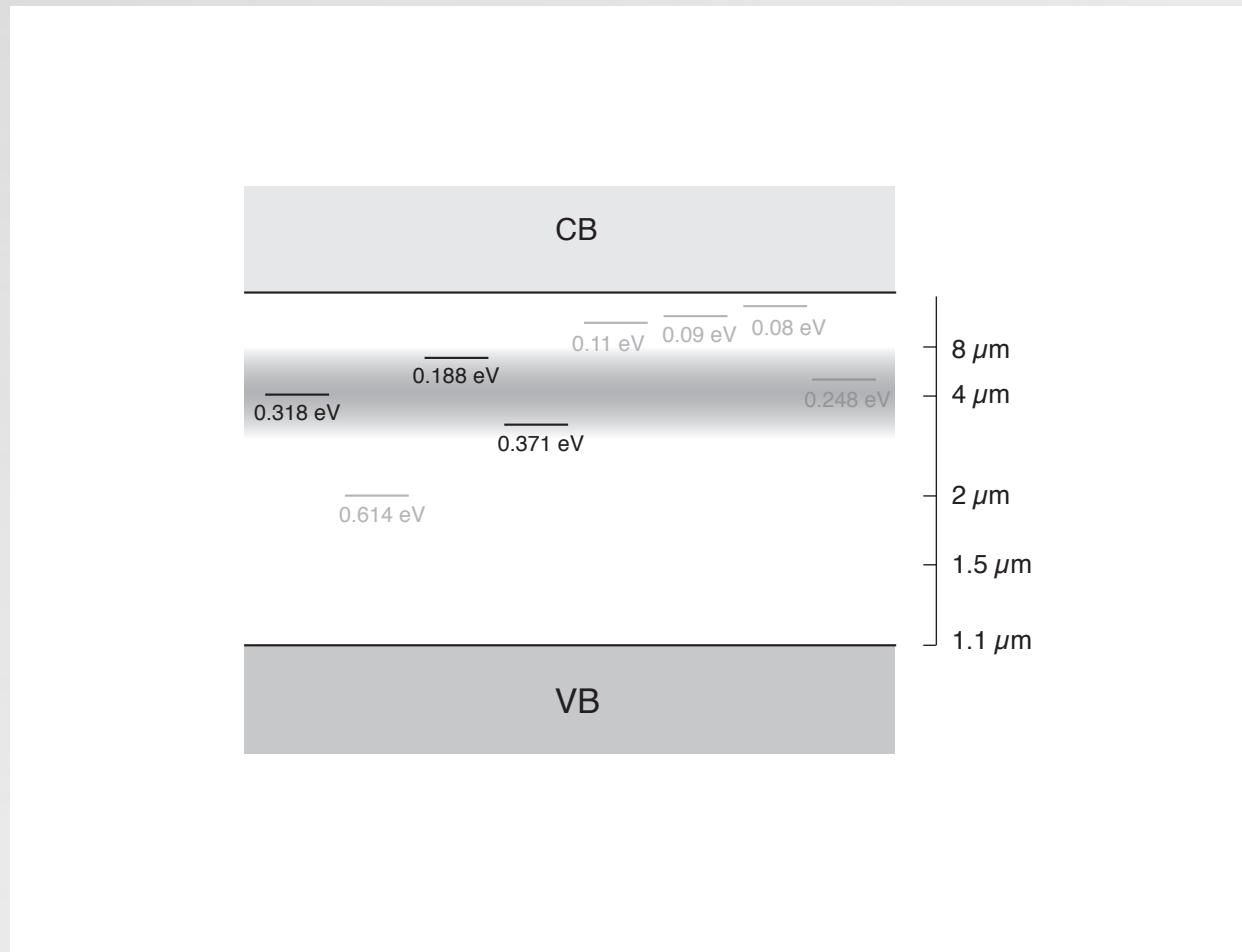
Janzén et al., Phys. Rev. B 29, 1907 (1984)

1 part in 10^6 sulfur introduces donor states in gap

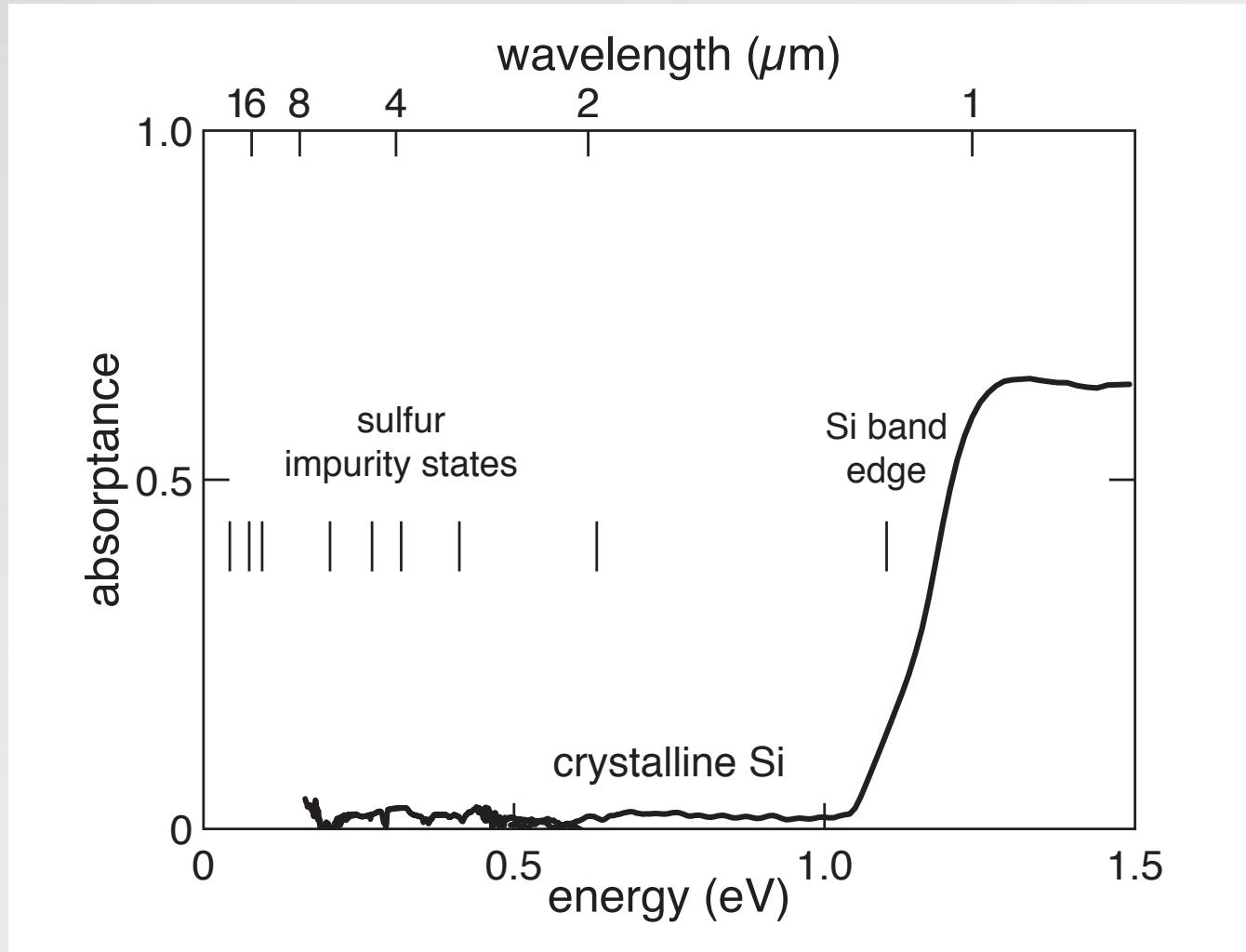


Janzén et al., Phys. Rev. B 29, 1907 (1984)

at high concentration states broaden into band

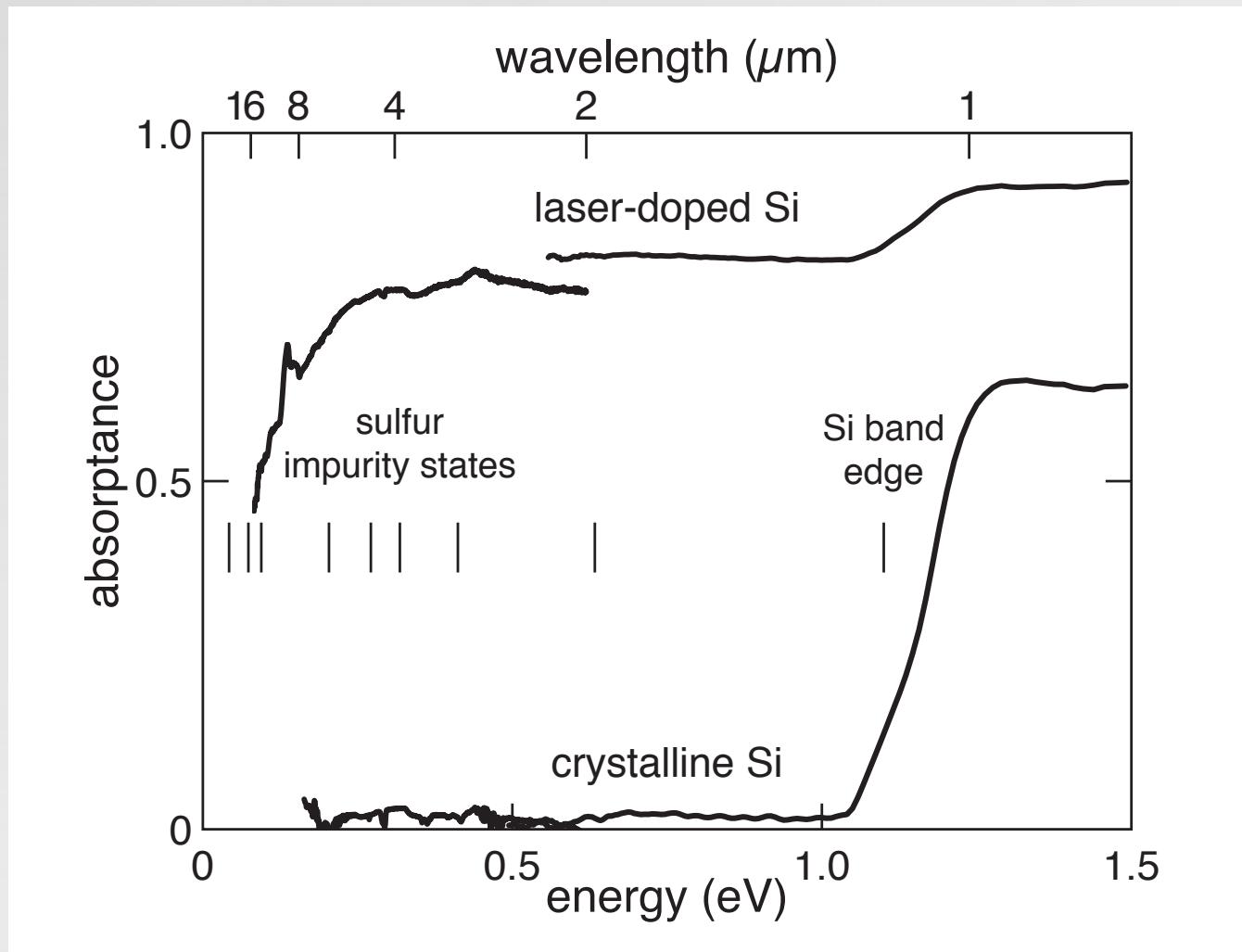


10^{-6} sulfur doping



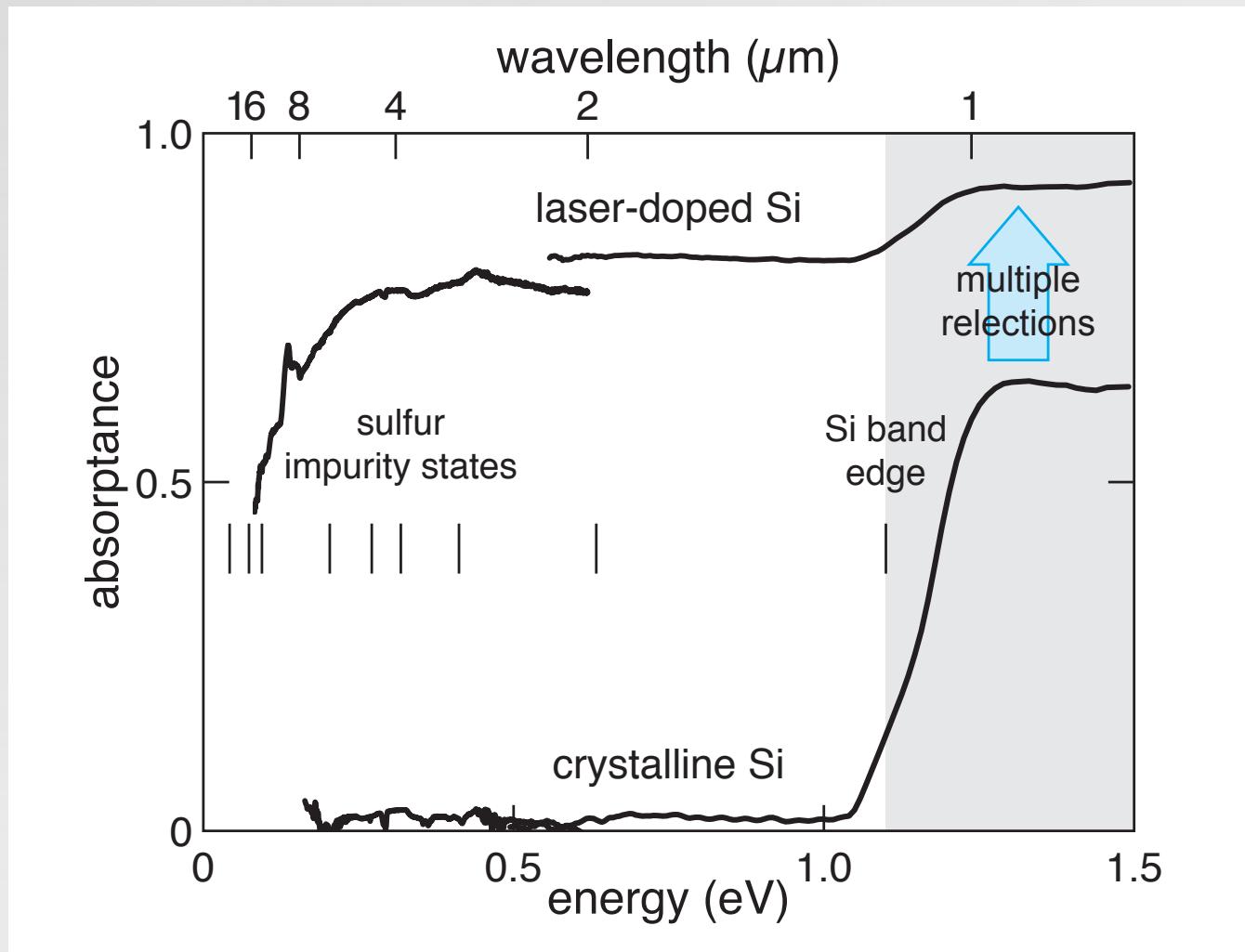
1 intermediate band

laser-doped S:Si



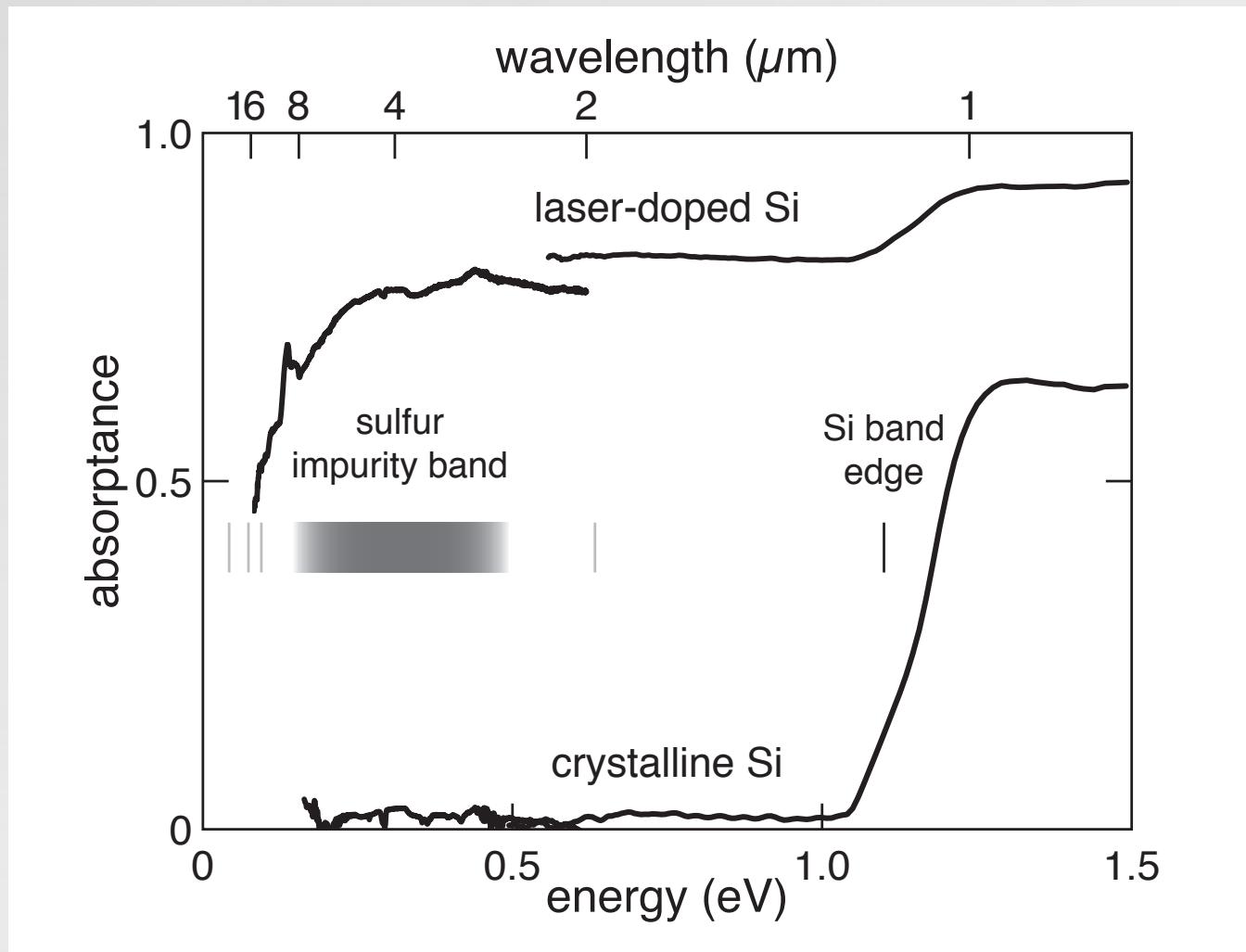
1 intermediate band

laser-doped S:Si



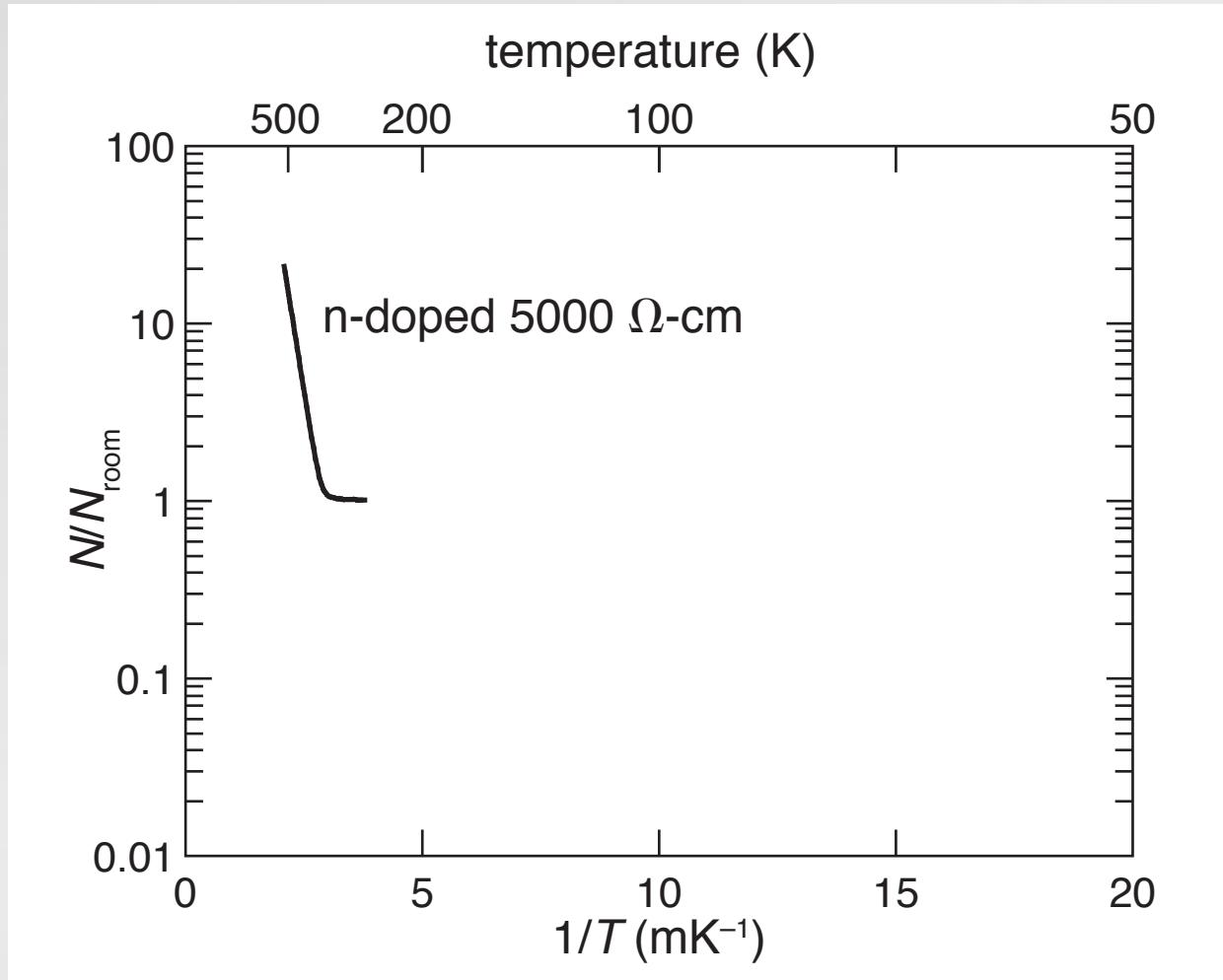
1 intermediate band

laser-doped S:Si



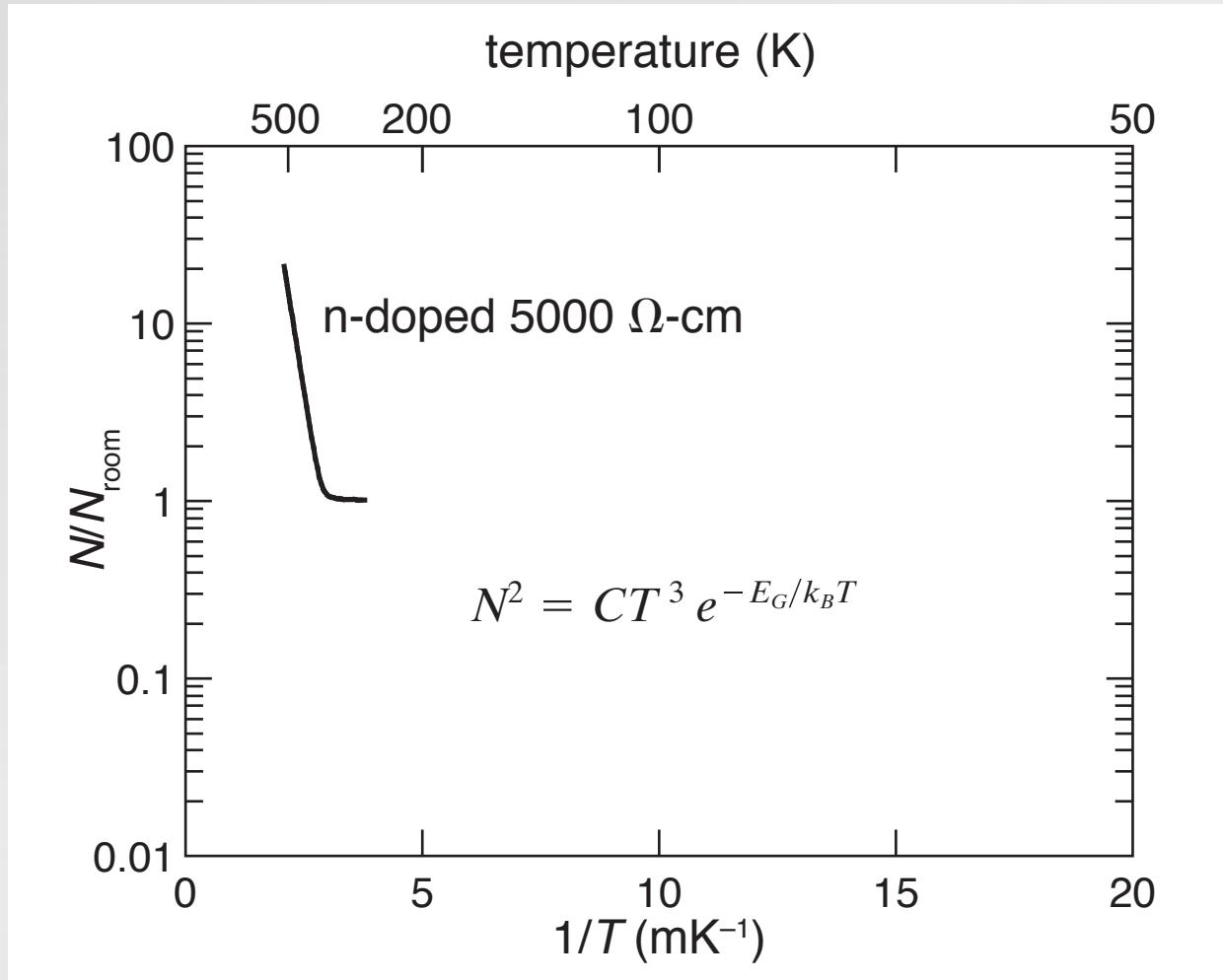
1 intermediate band

Hall measurements

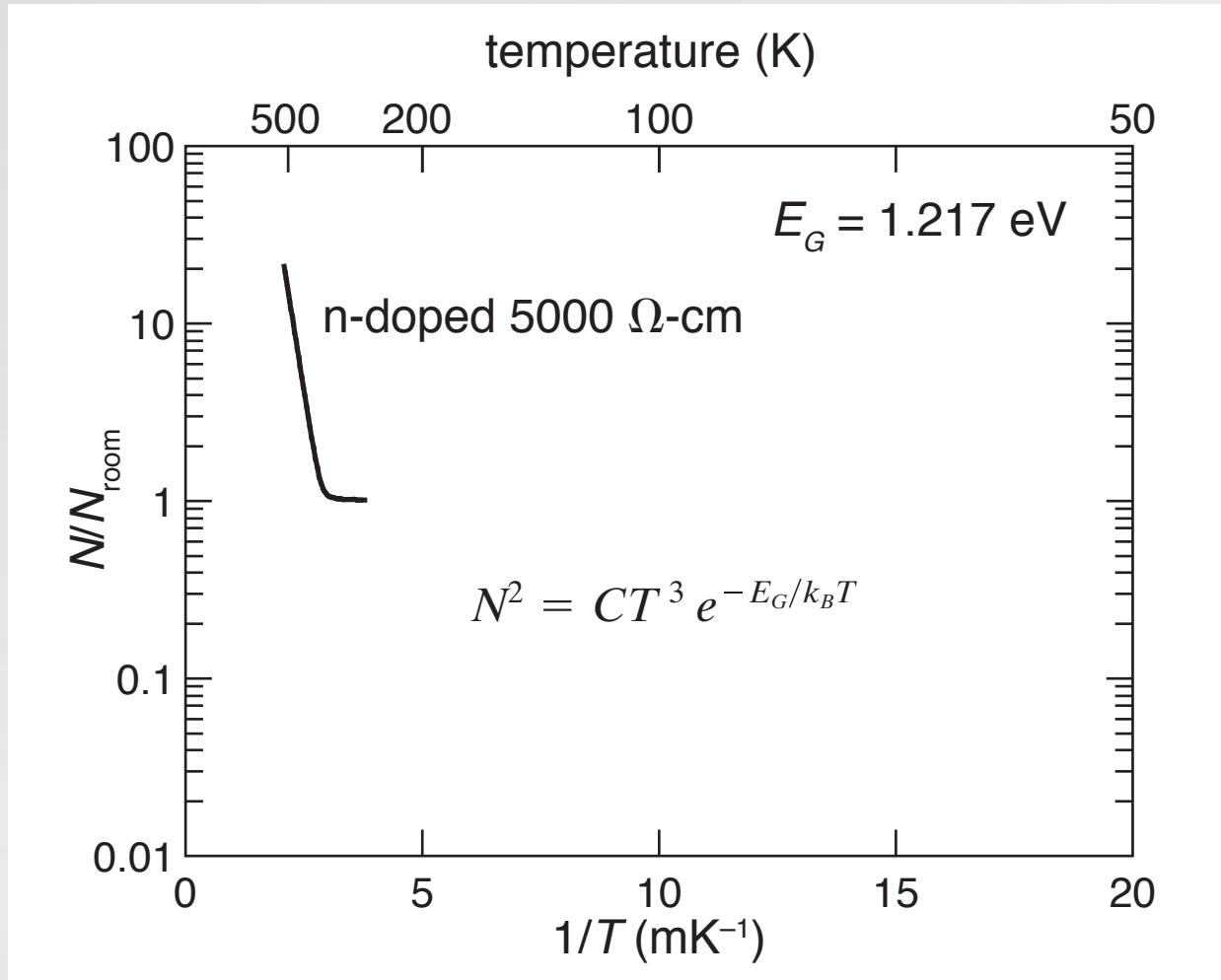


1 intermediate band

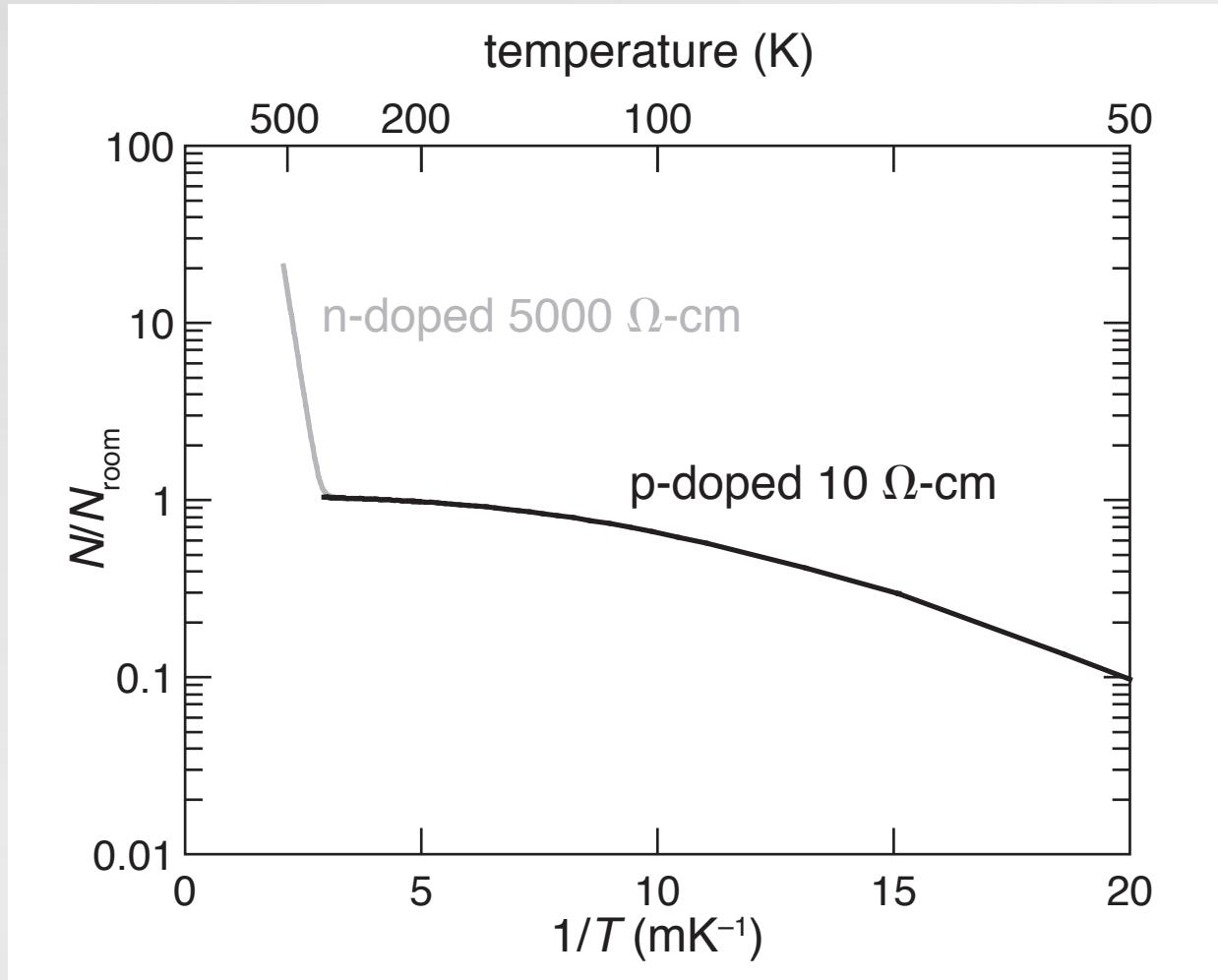
Hall measurements



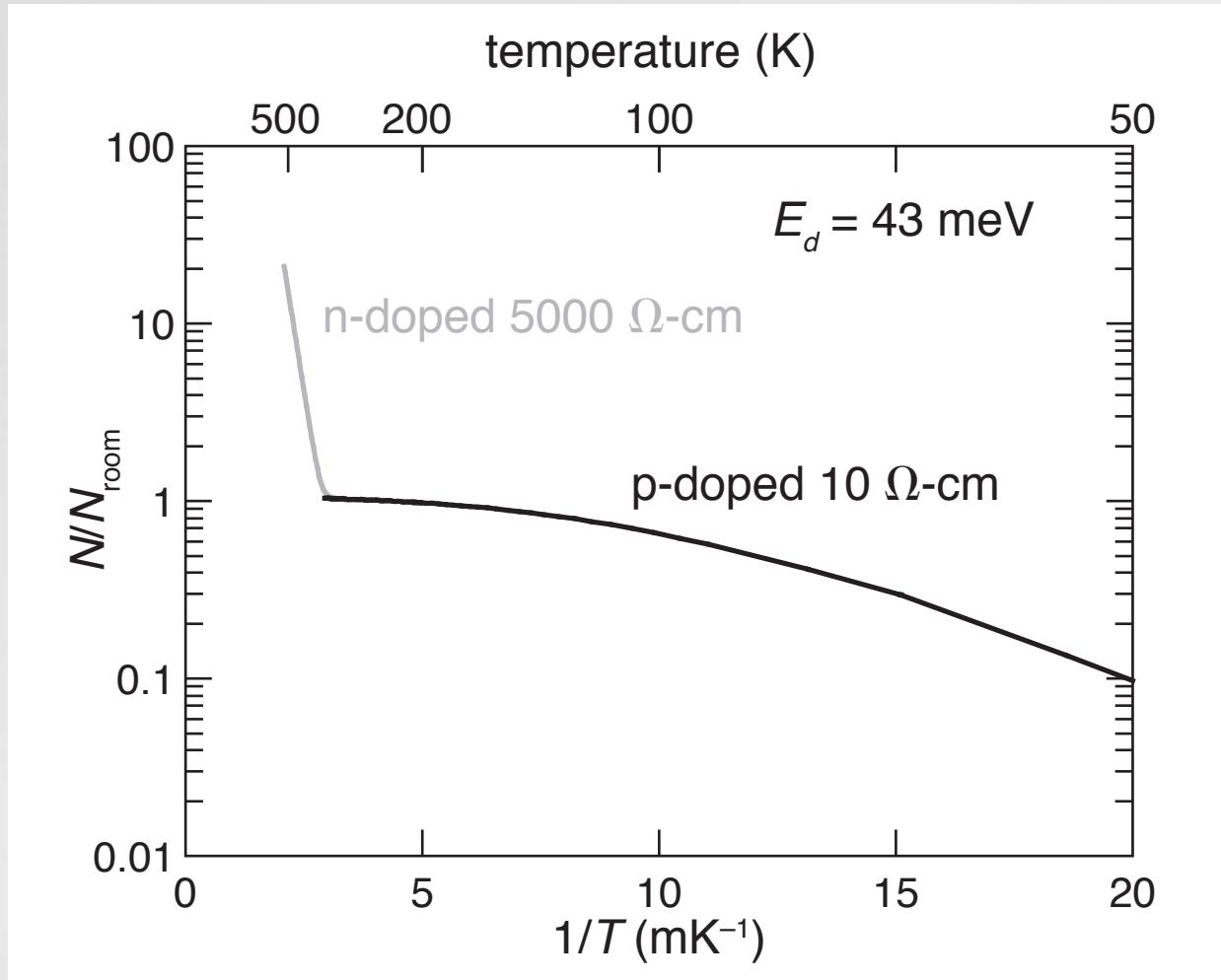
Hall measurements



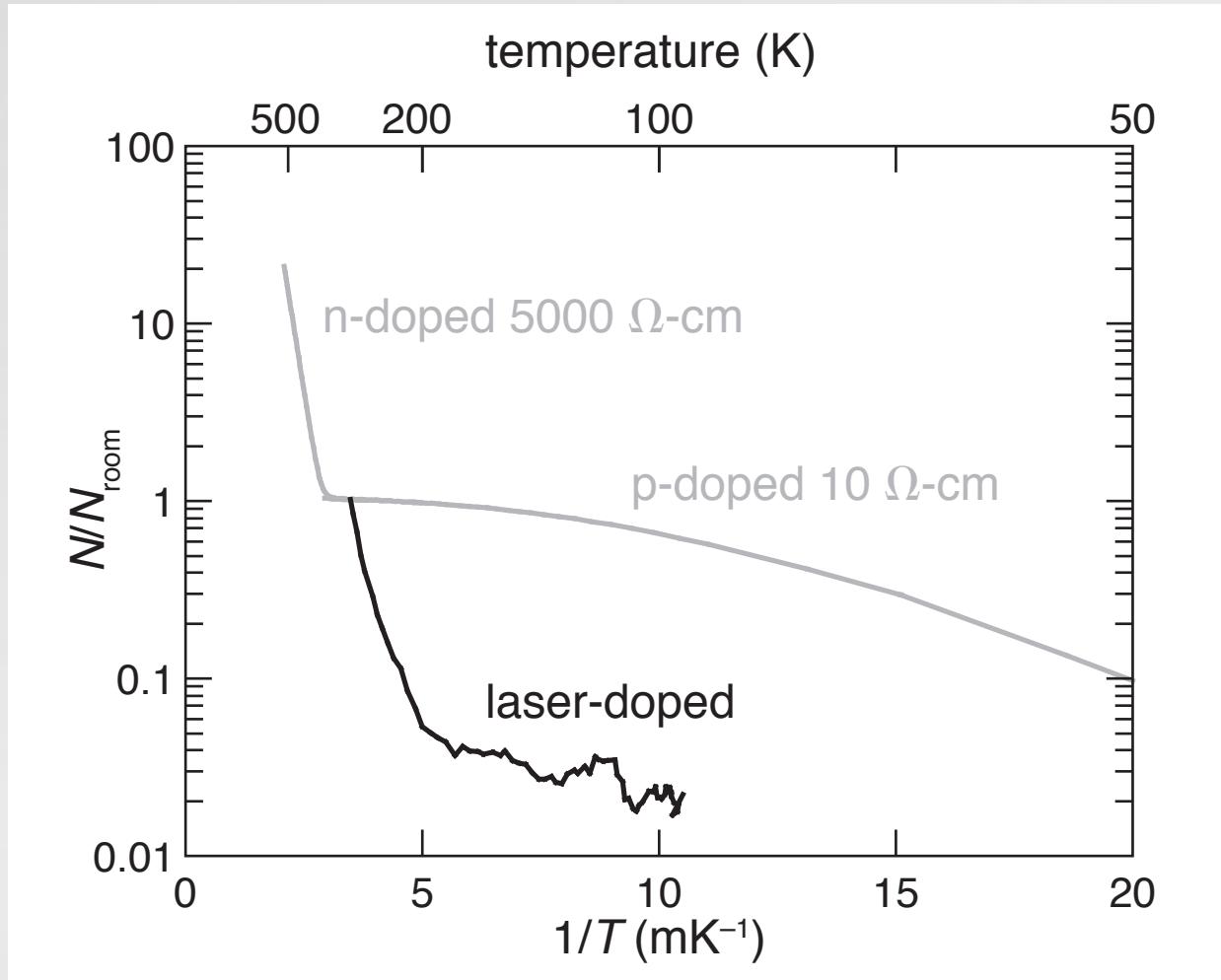
Hall measurements



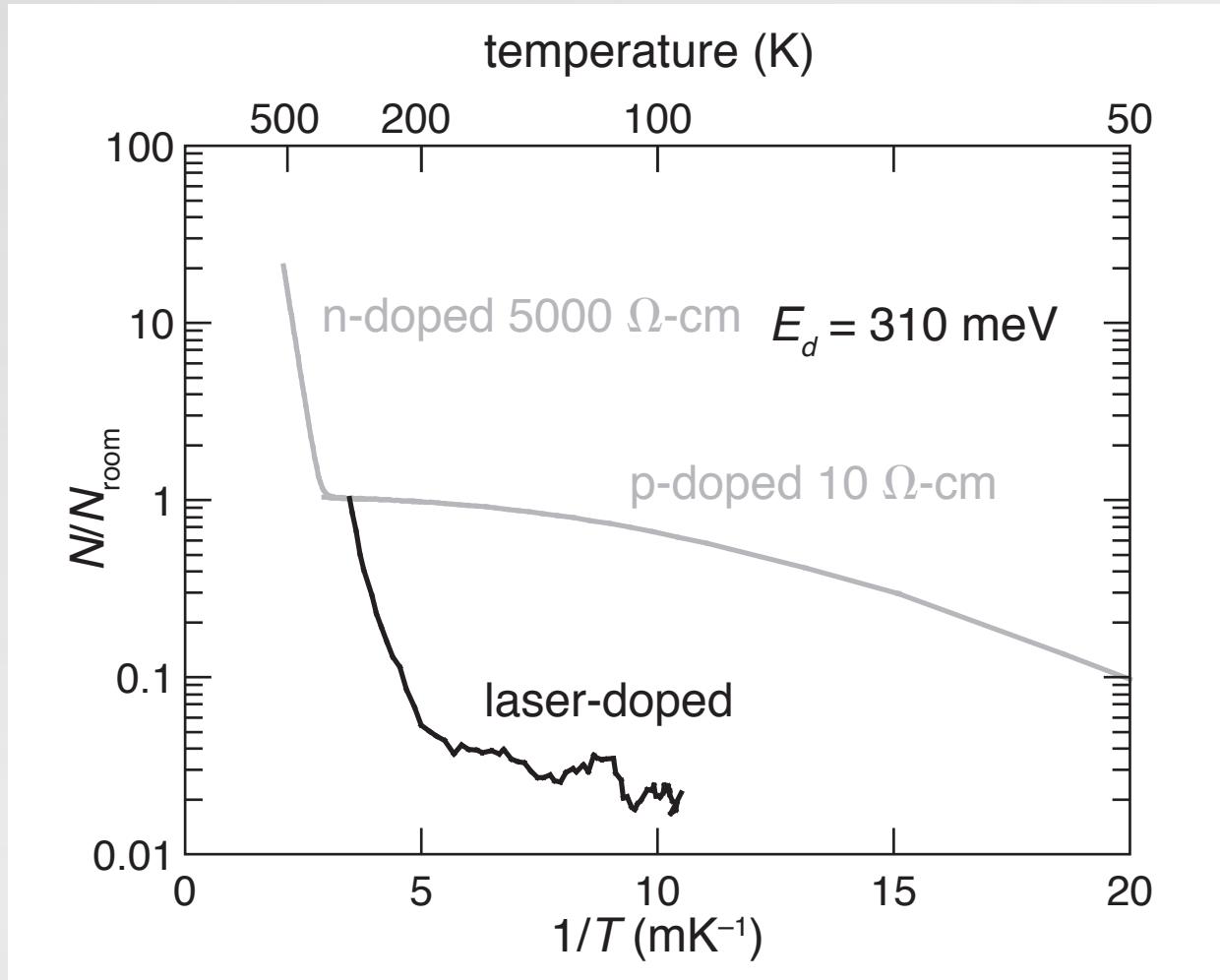
Hall measurements



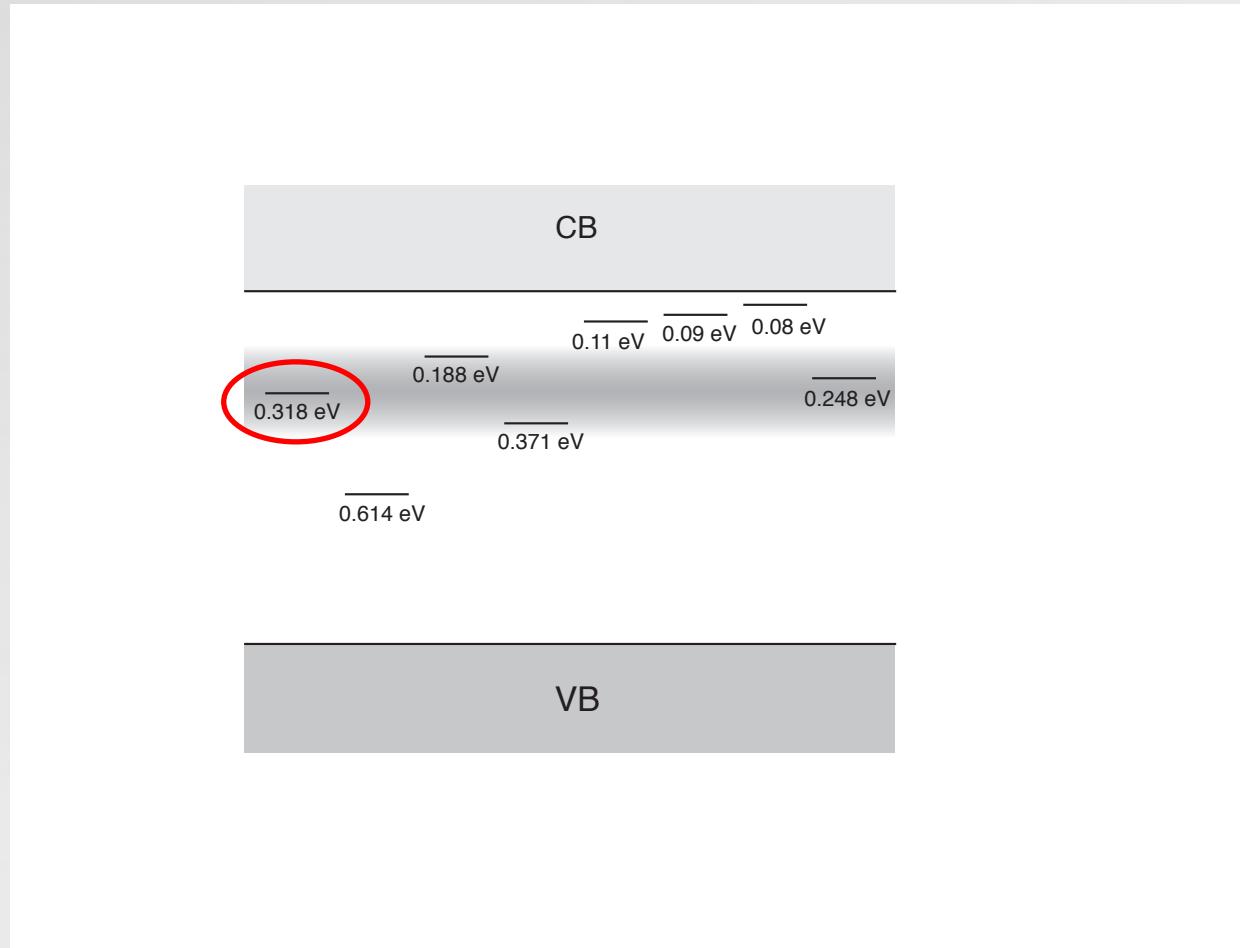
Hall measurements



Hall measurements

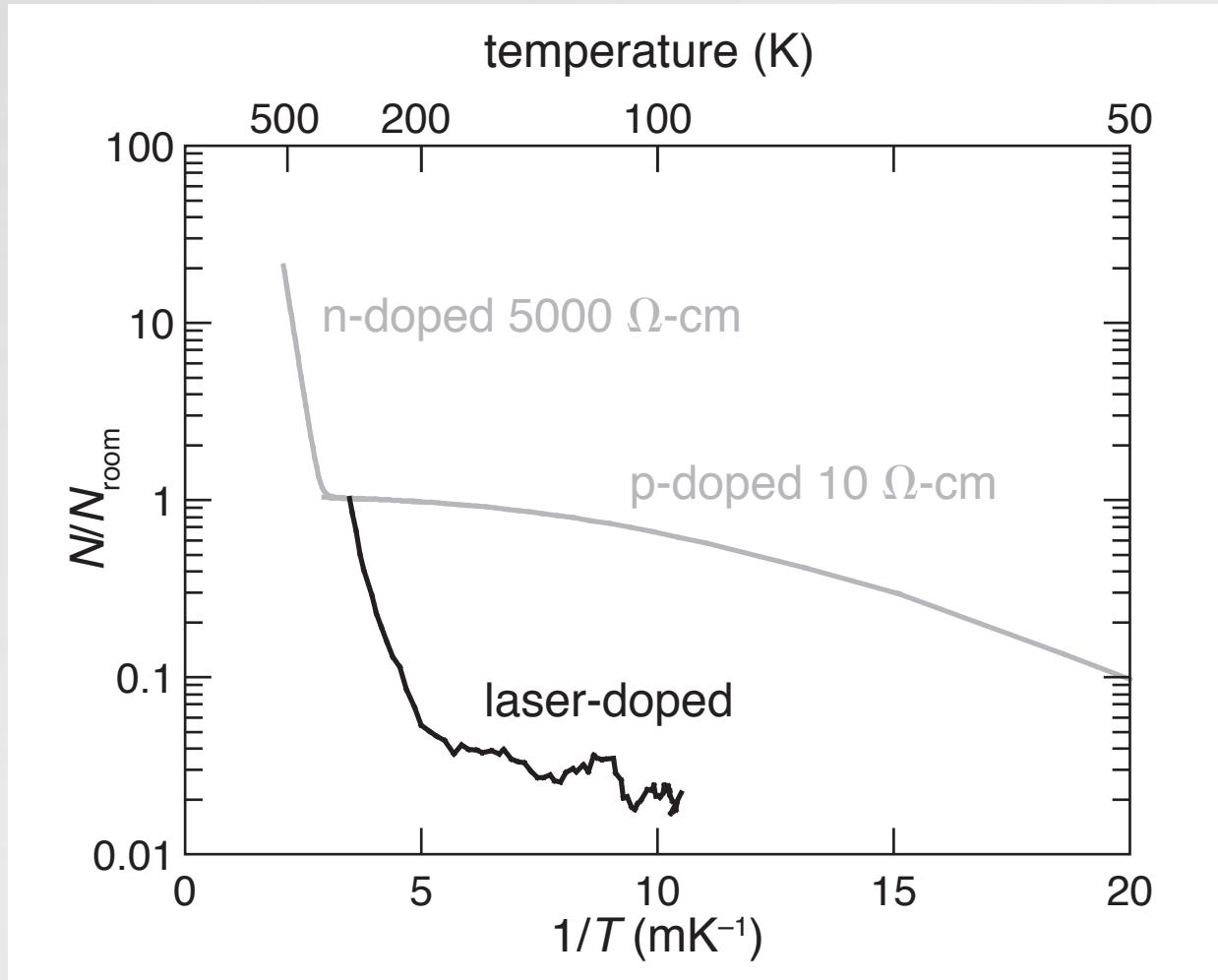


impurity (donor) band centered at 310 meV

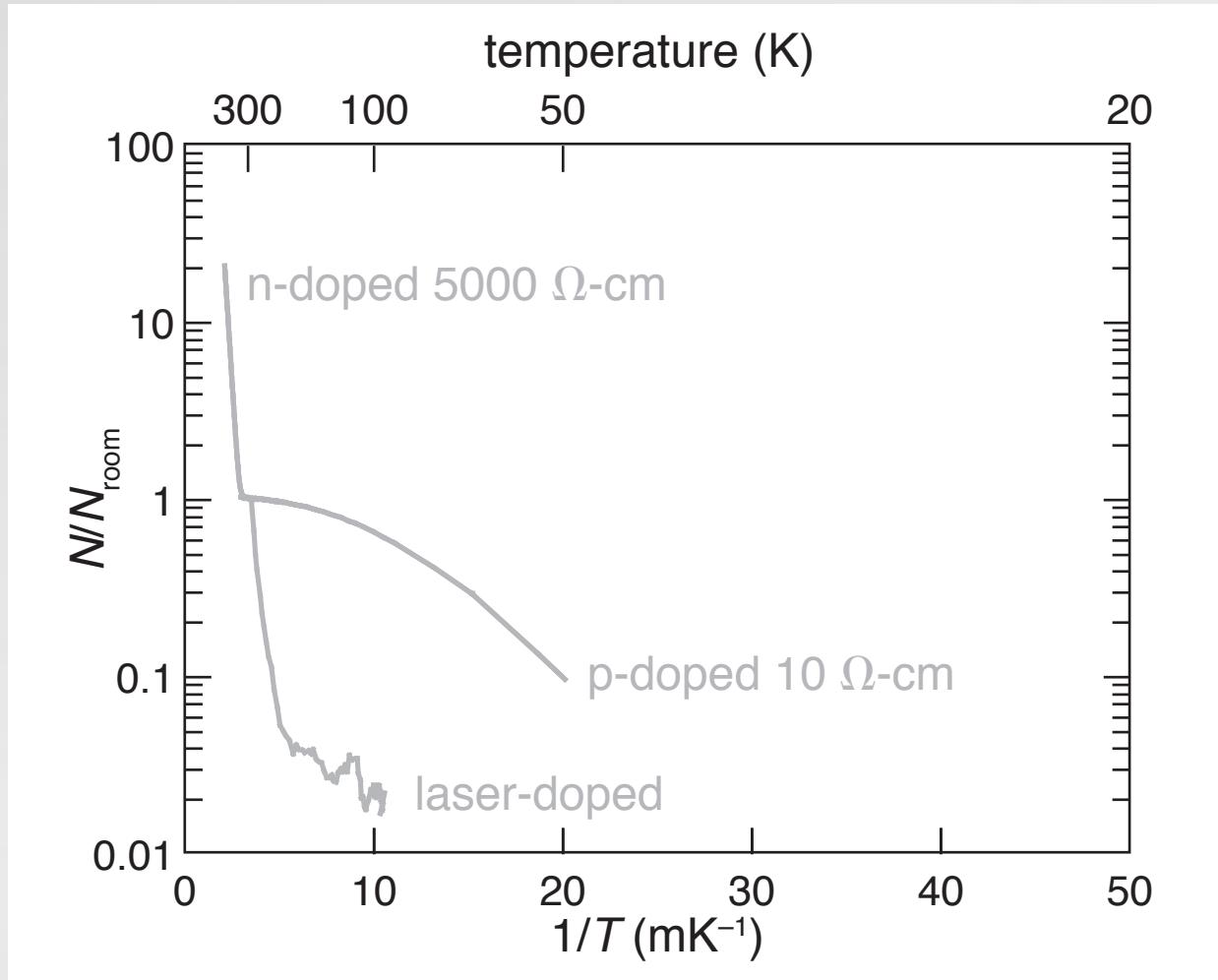


1 intermediate band

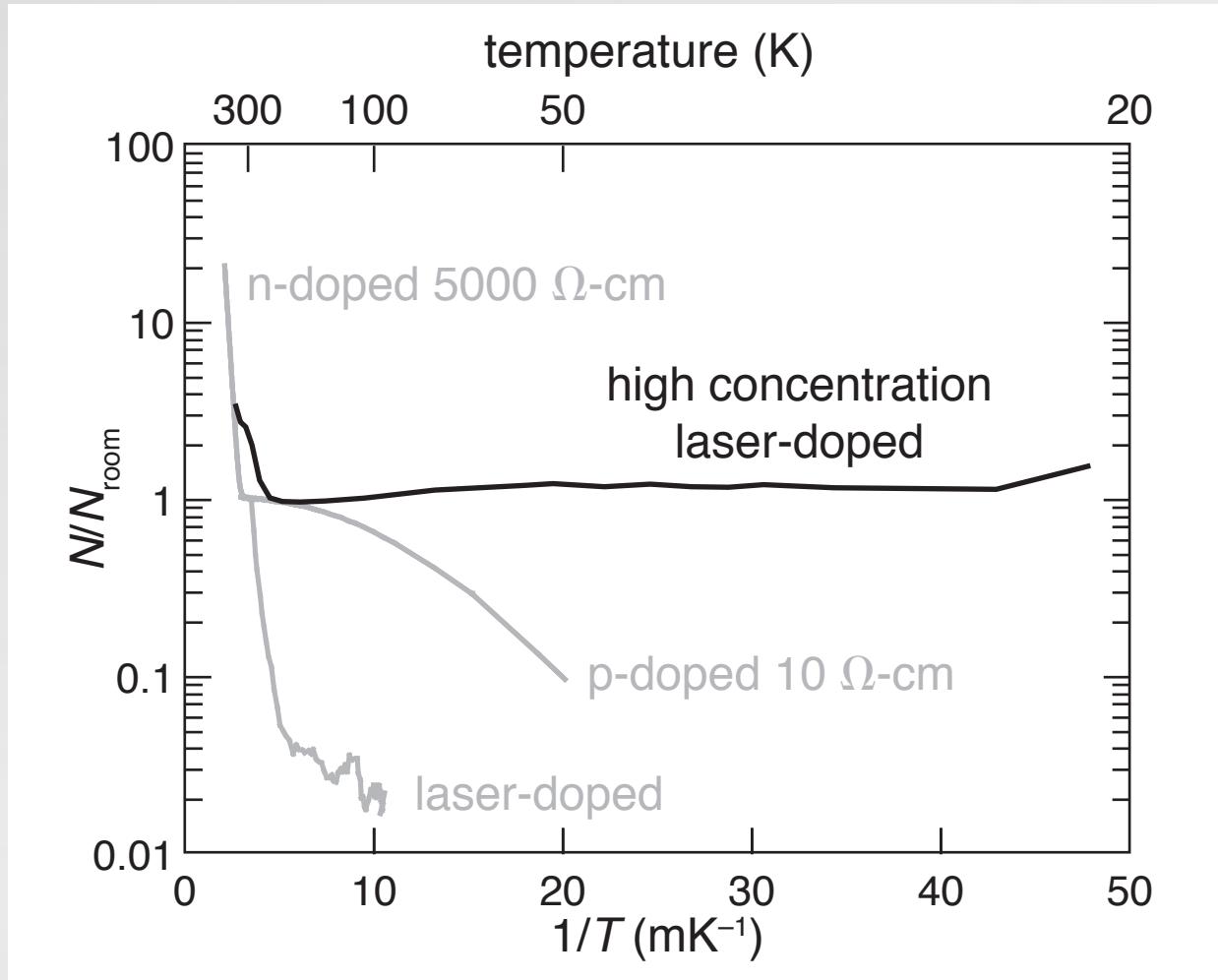
Hall measurements



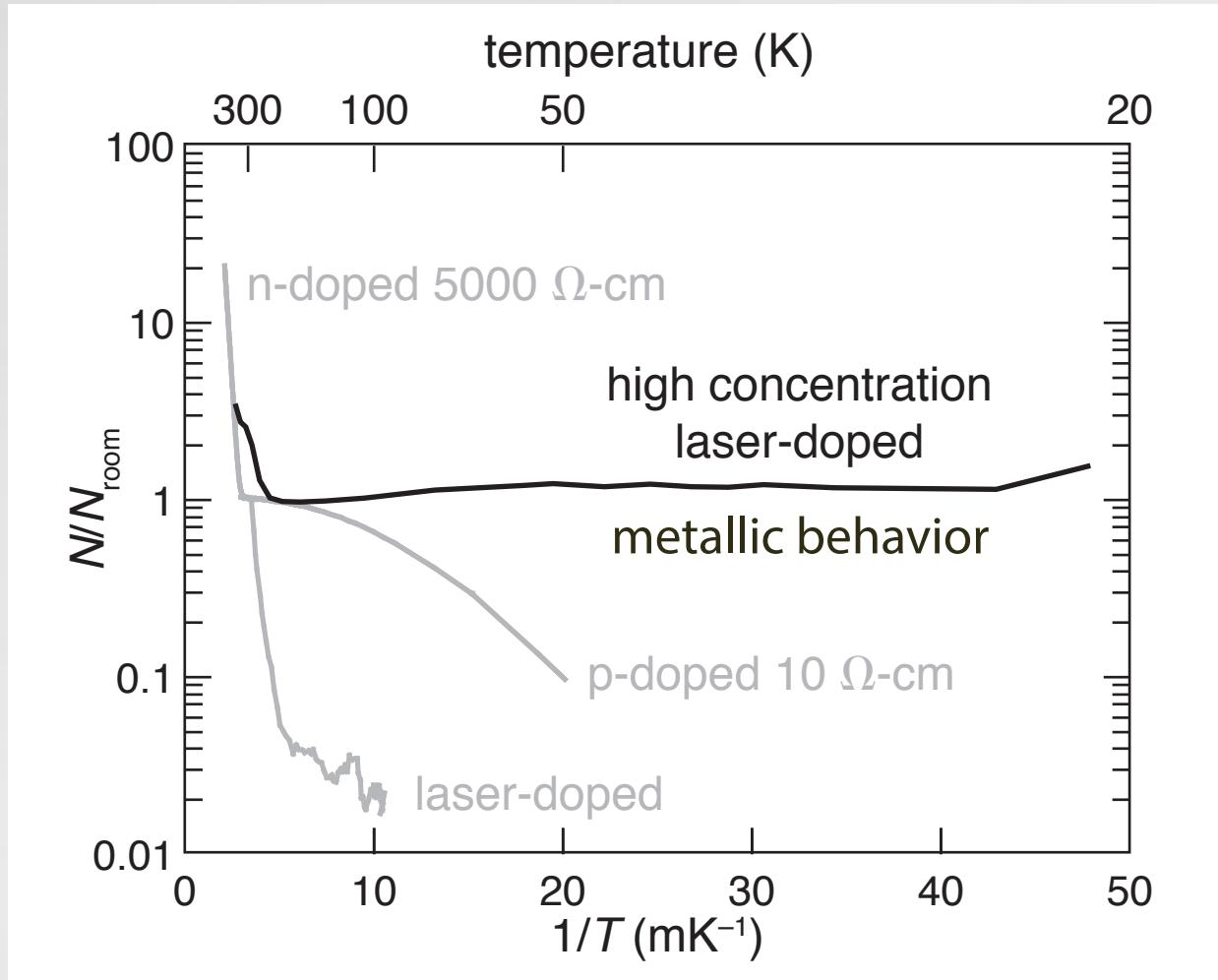
Hall measurements



Hall measurements

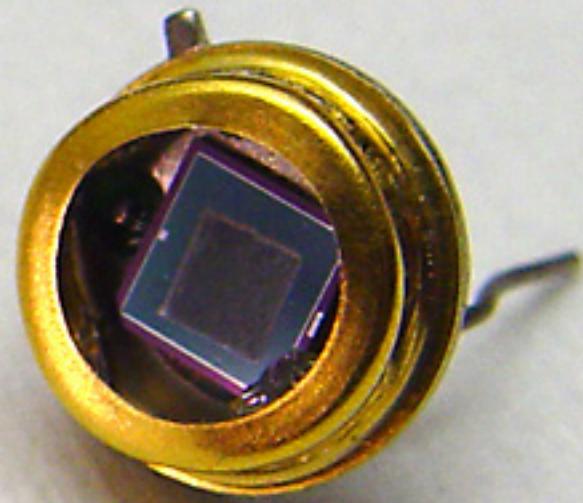
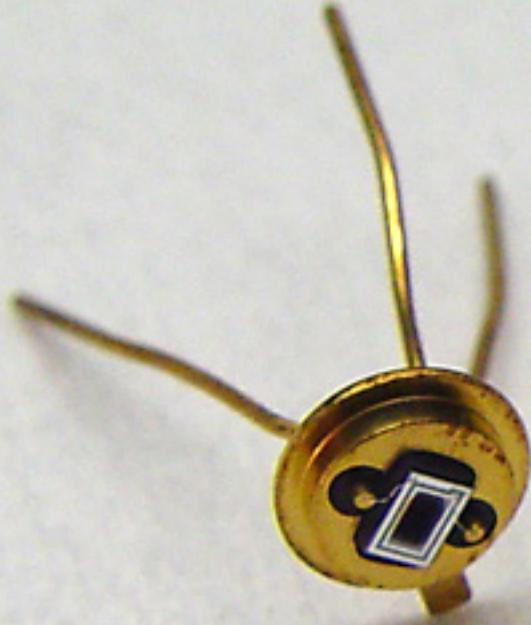


Hall measurements



Things to keep in mind

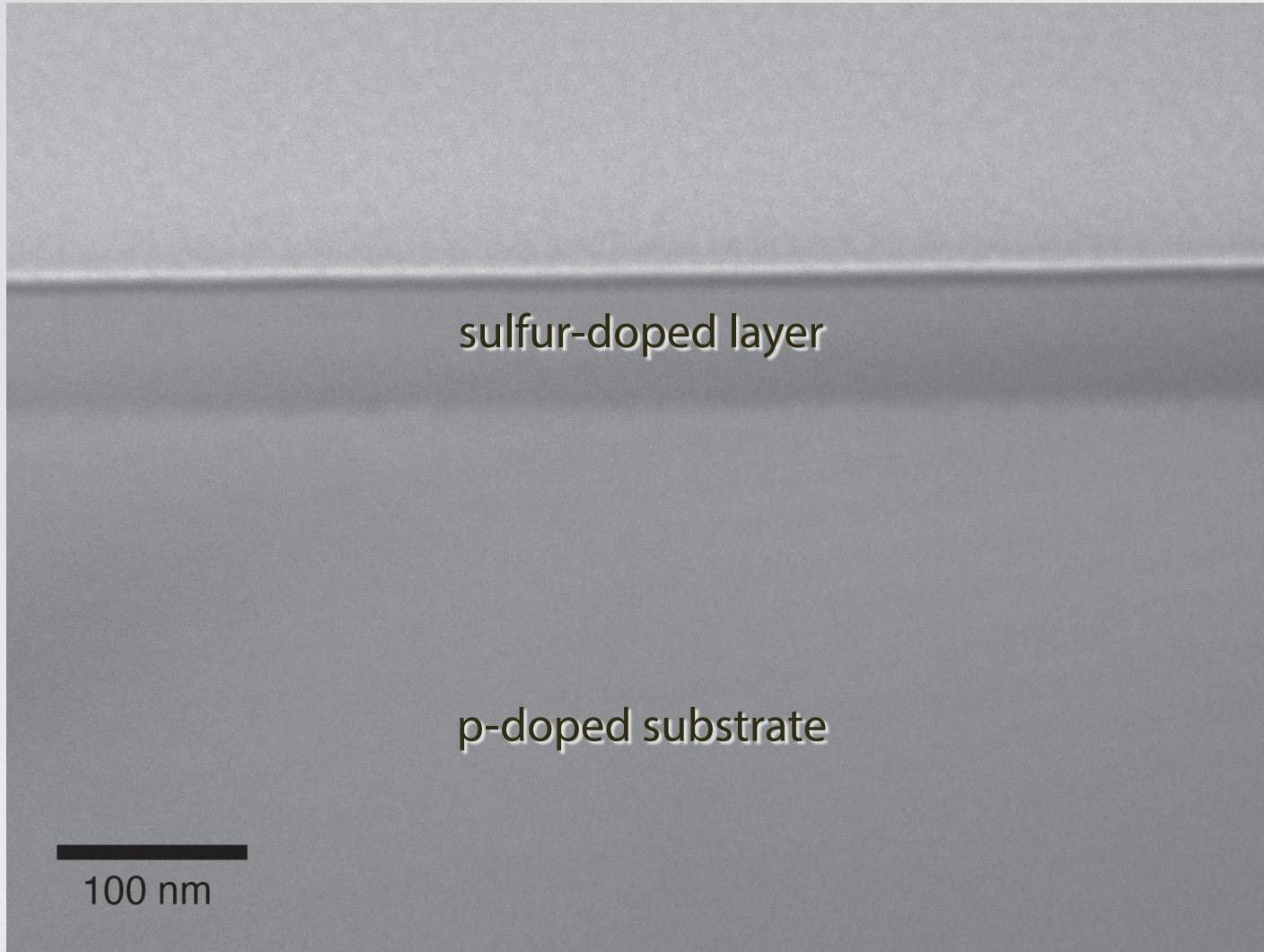
- IR absorption rolls off around $8 \mu\text{m}$
- evidence of intermediate band formation
- intermediate band due to substitutional S donors
- intermediate band 0–300 meV below CB



1 intermediate band

2 Si devices

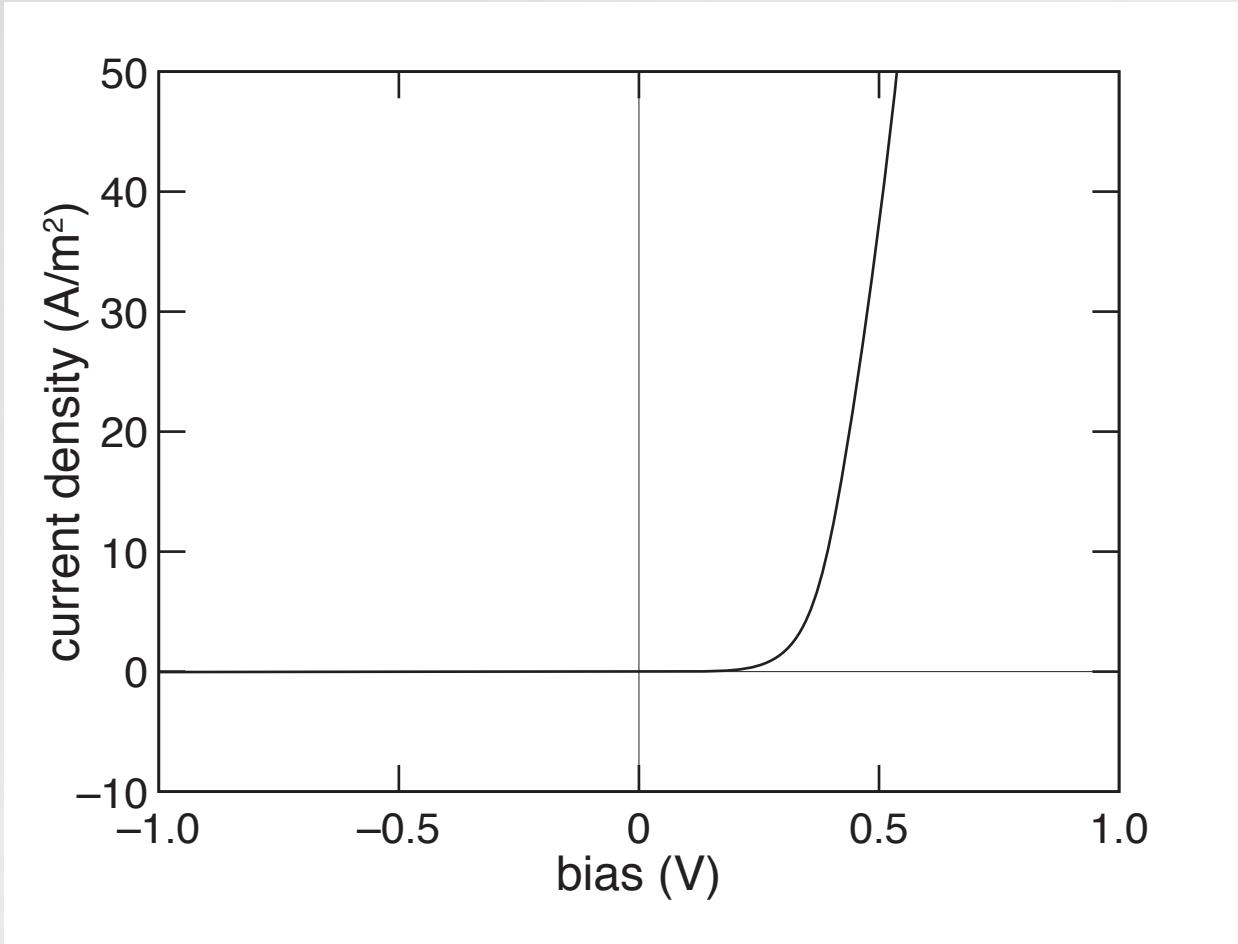
should have shallow junction below surface



1 intermediate band

2 Si devices

excellent rectification (after annealing)



1 intermediate band

2 Si devices



<http://www.sionyx.com>

1 intermediate band

2 Si devices

Potential benefits for photovoltaics

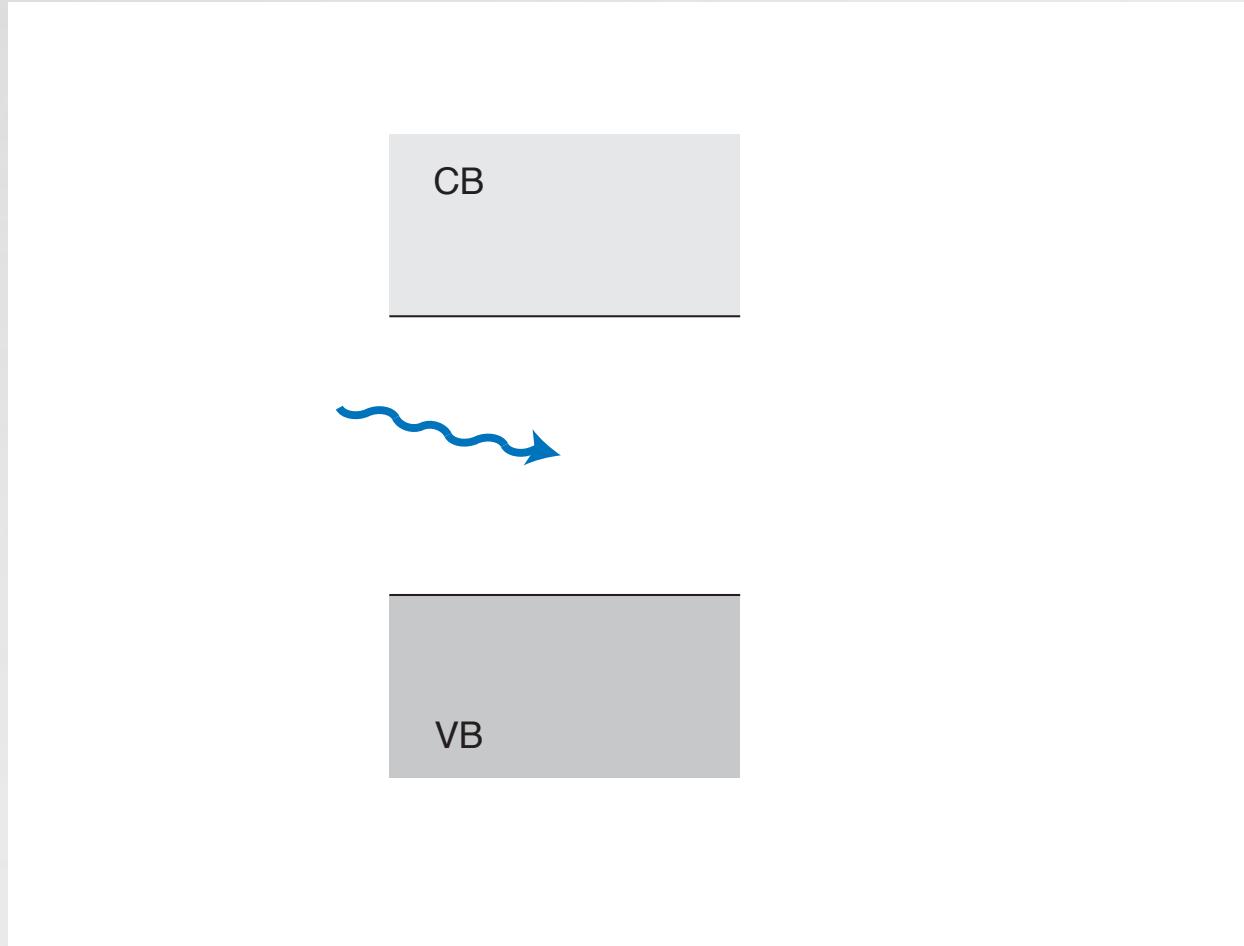
- surface structure
- absorption in submicrometer layer
- extended IR absorption
- intermediate band



1 intermediate band

2 Si devices

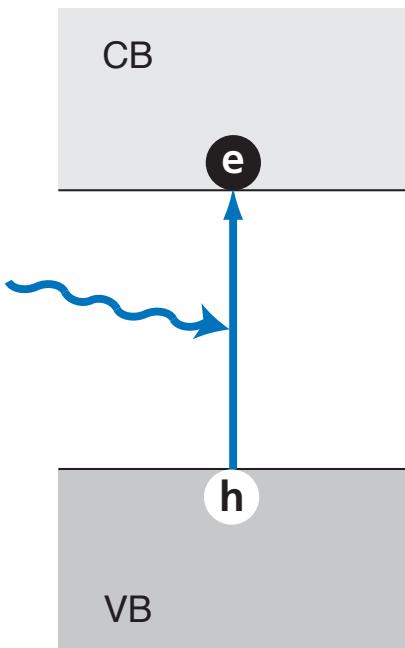
photon with gap energy



1 intermediate band

2 Si devices

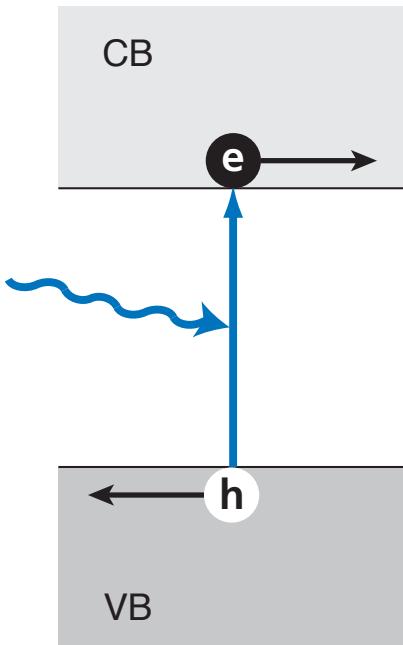
photon creates electron-hole pair...



1 intermediate band

2 Si devices

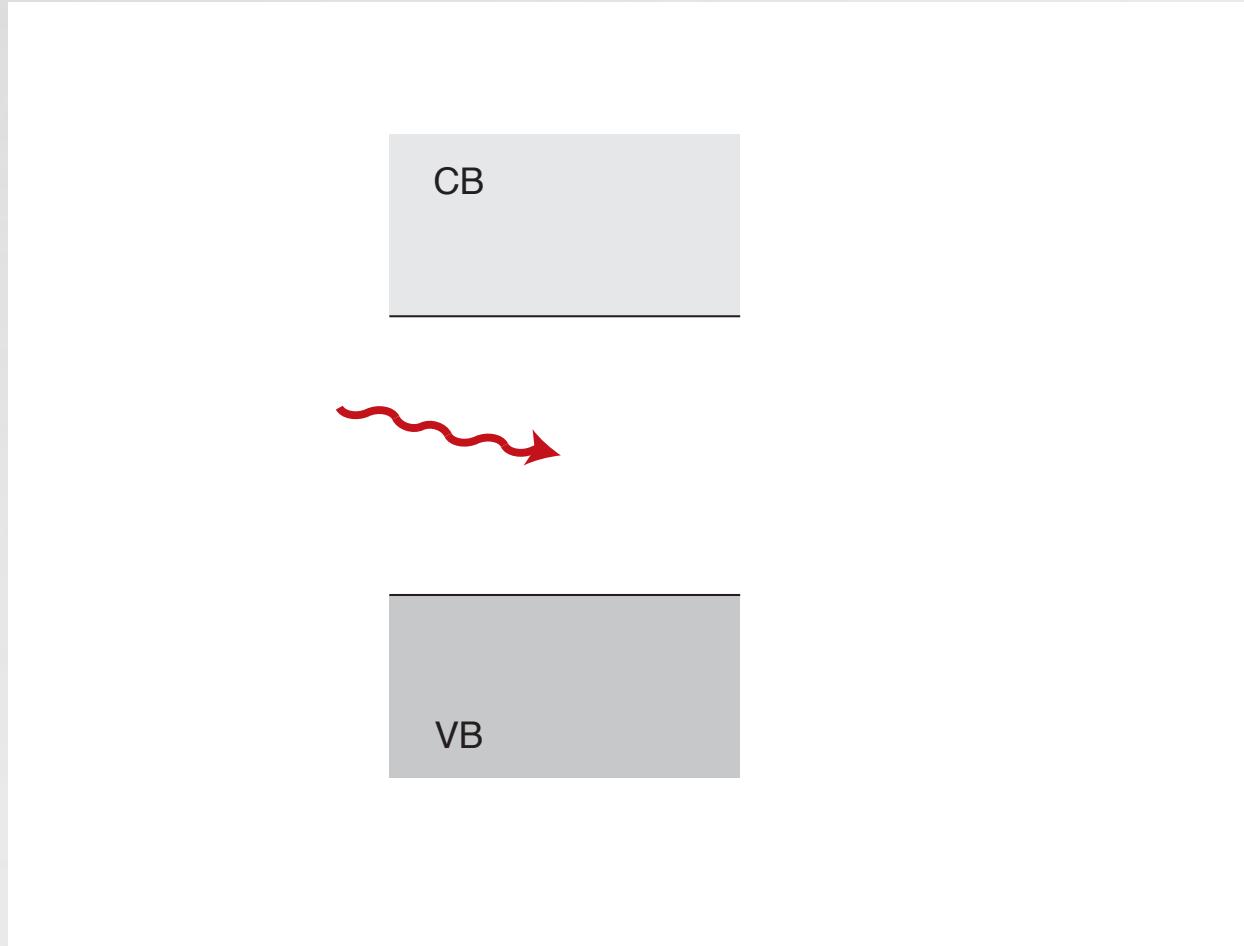
...whose energy can be extracted



1 intermediate band

2 Si devices

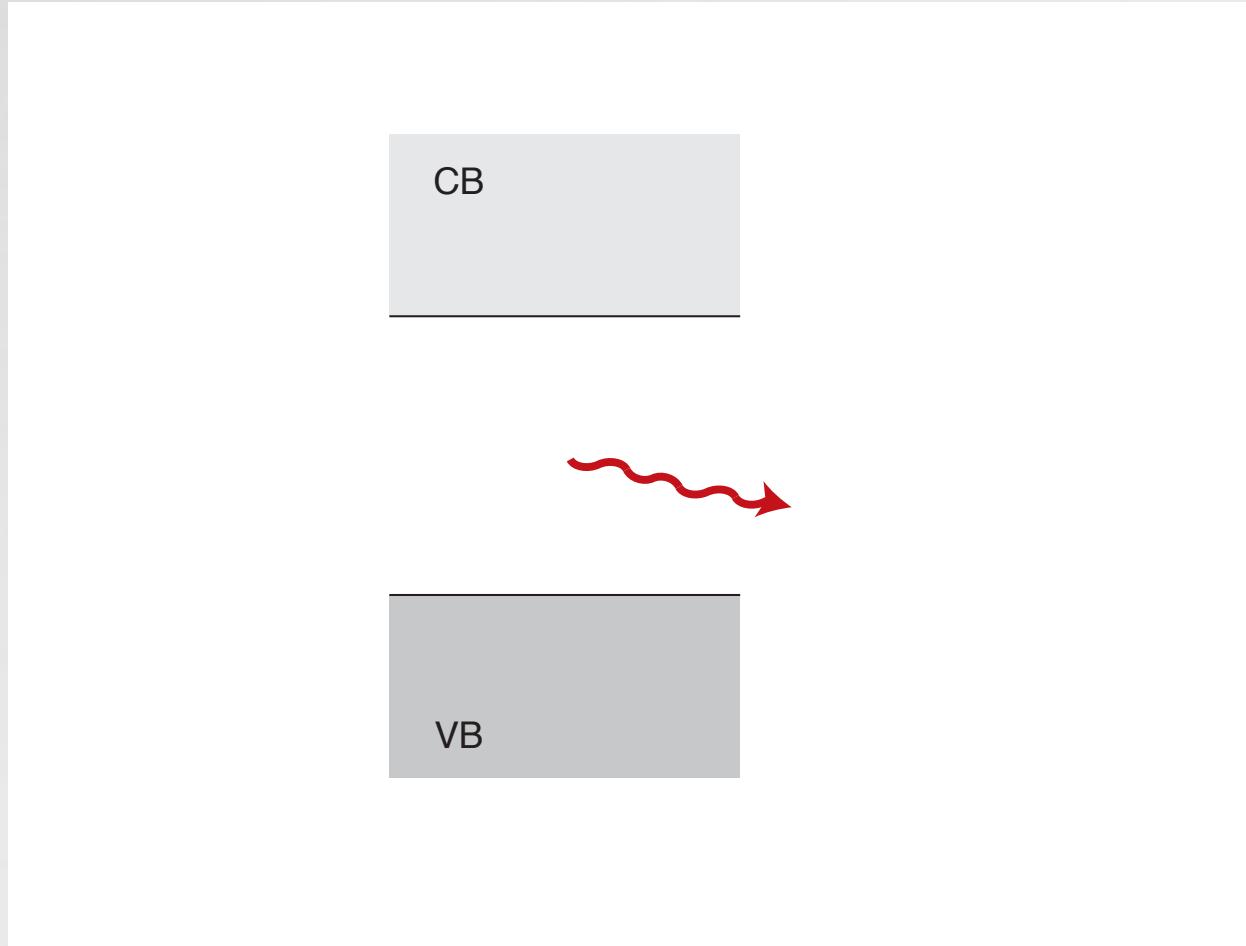
photons with energy smaller than gap...



1 intermediate band

2 Si devices

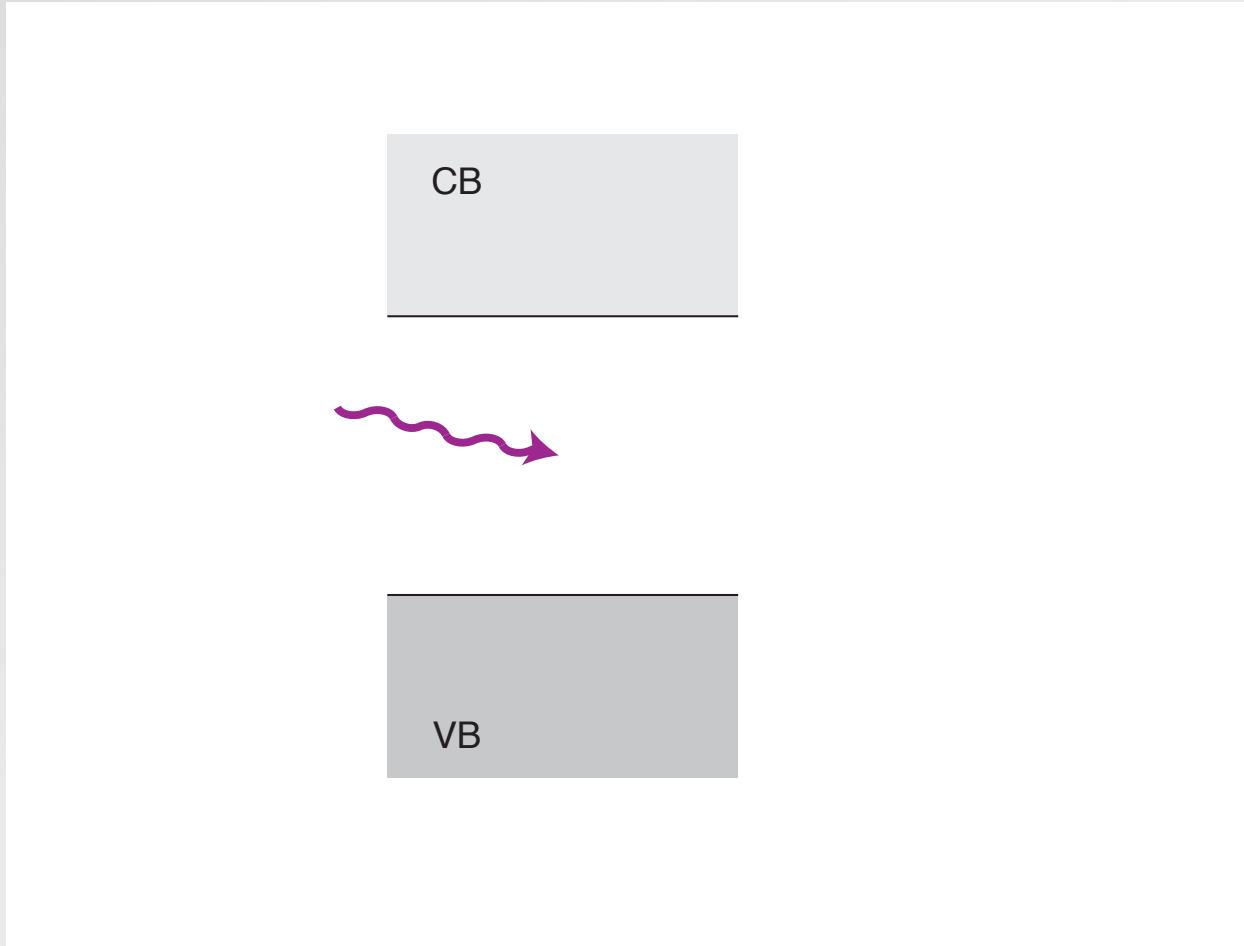
...do not get absorbed



1 intermediate band

2 Si devices

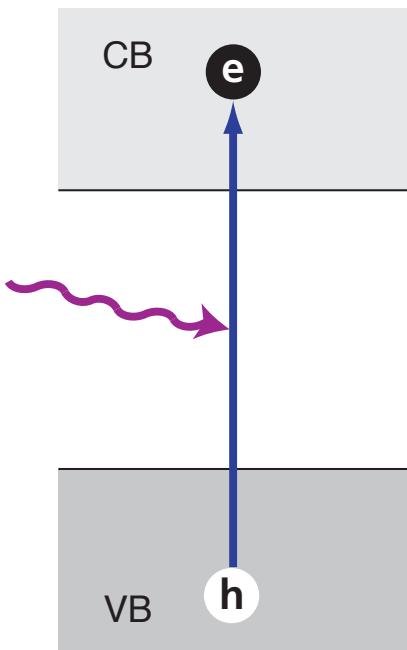
photons with energy larger than the gap...



1 intermediate band

2 Si devices

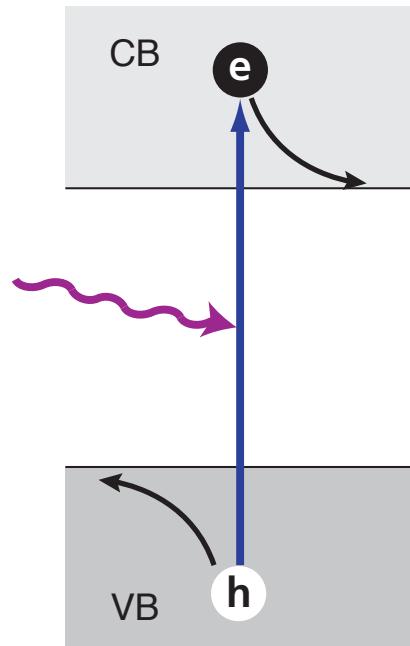
...create electron-hole pairs with excess energy...



1 intermediate band

2 Si devices

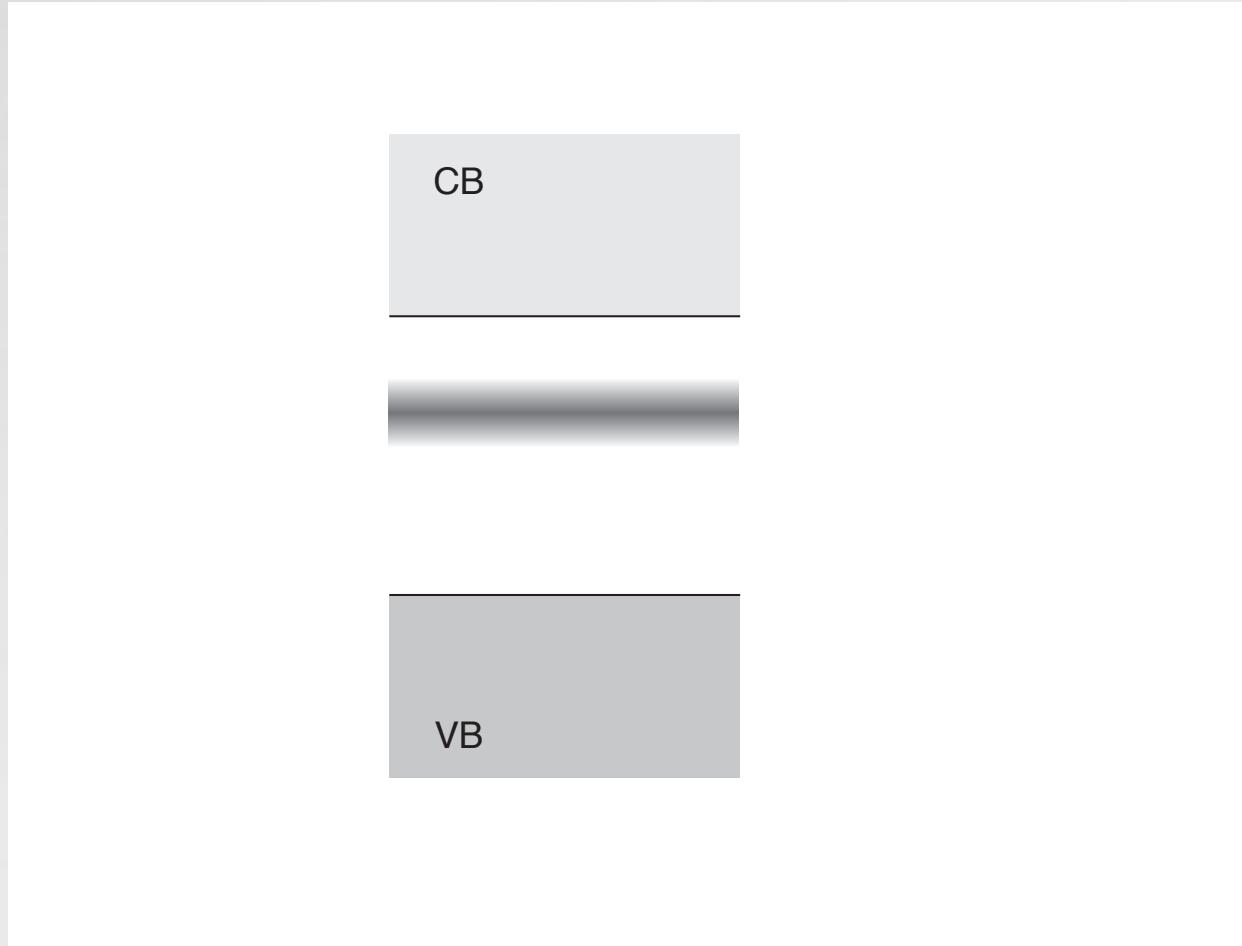
...which is lost rapidly



1 intermediate band

2 Si devices

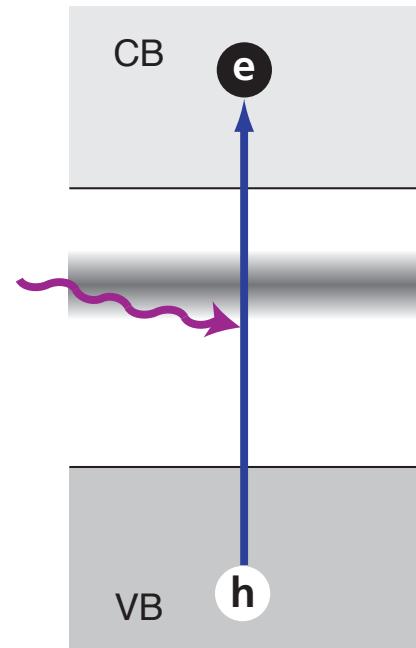
black silicon has an intermediate band



1 intermediate band

2 Si devices

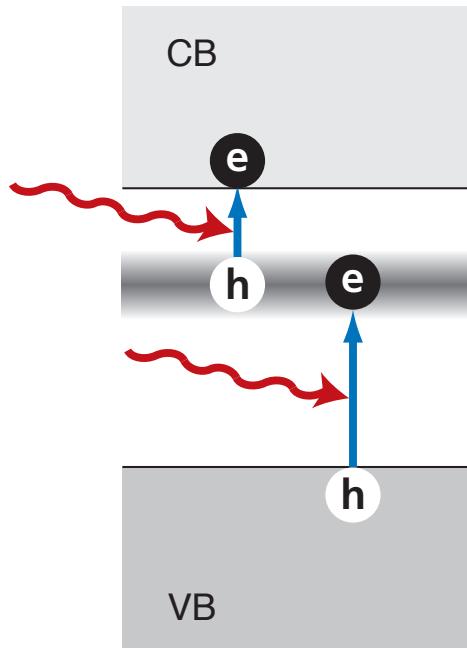
absorbs same photons as ordinary silicon...



1 intermediate band

2 Si devices

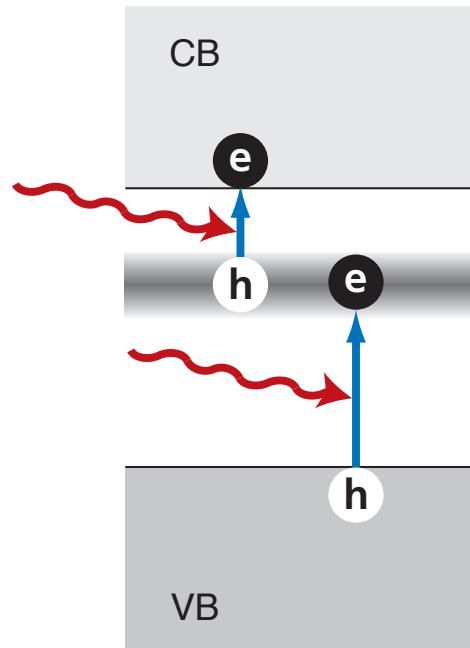
...but extends absorption to longer wavelengths



1 intermediate band

2 Si devices

could theoretically get efficiencies over 50%

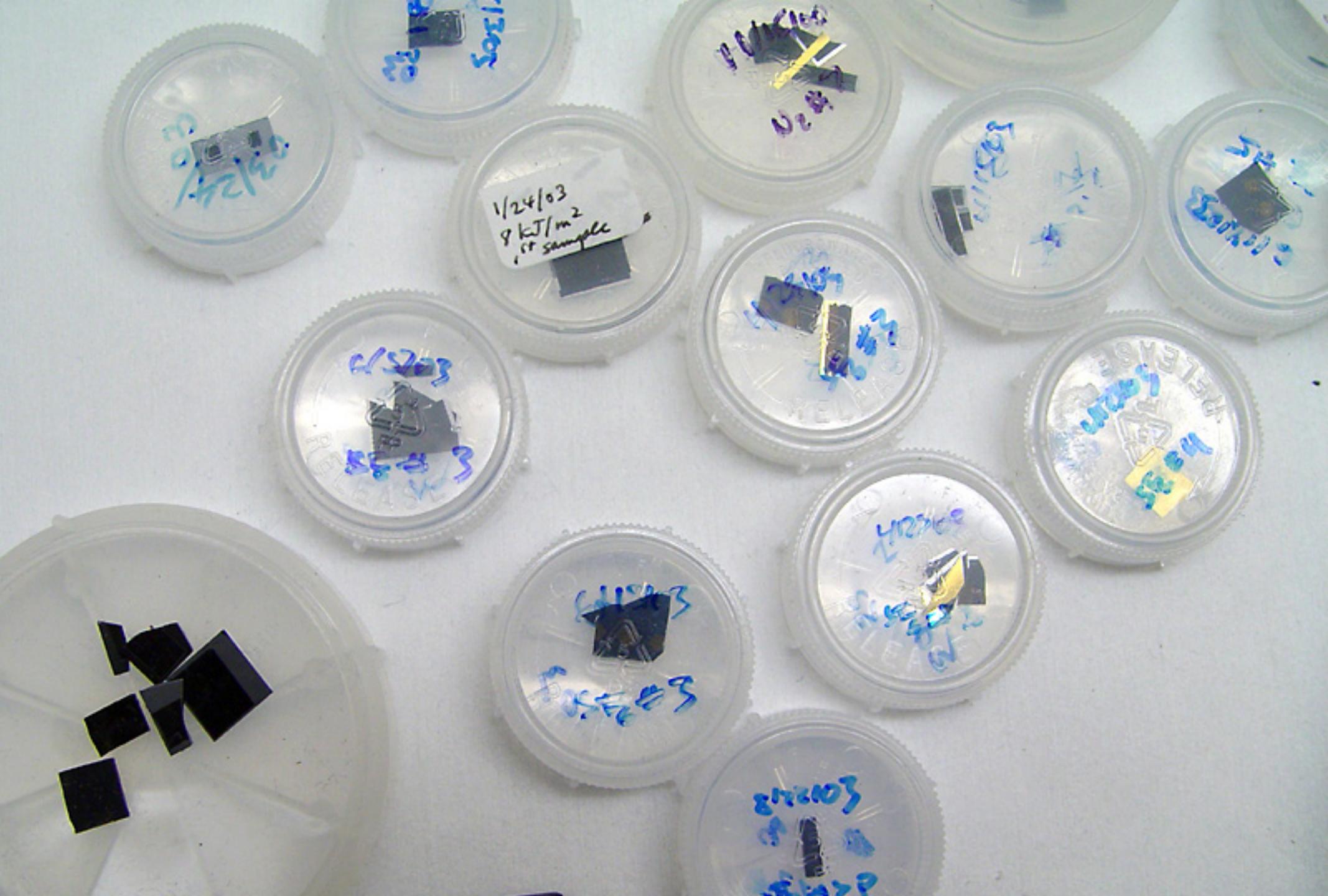


1 intermediate band

2 Si devices

Things to keep in mind

- can turn absorption into carrier generation (photodetectors)
- very high optical density
- intermediate band photovoltaic devices?

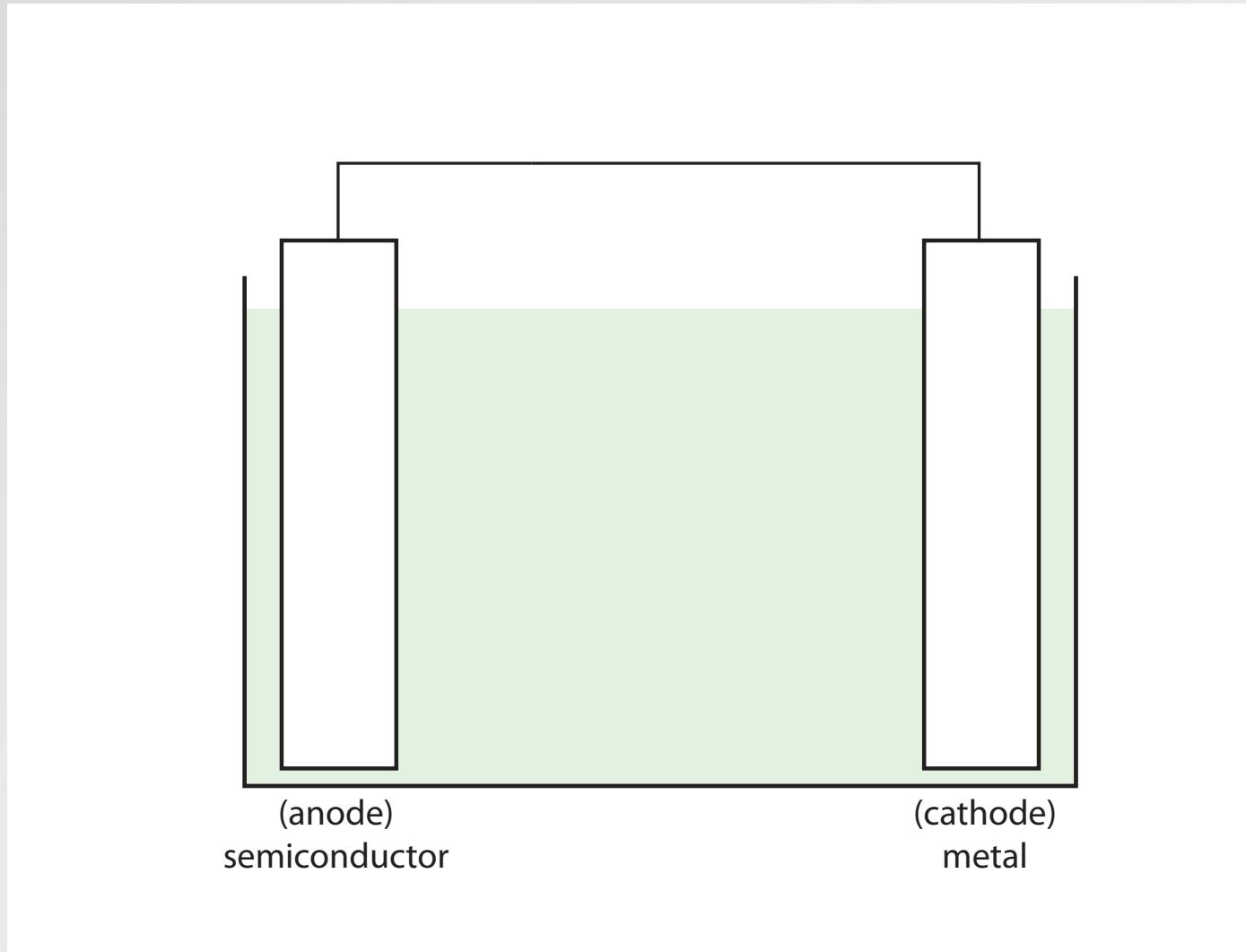


1 intermediate band

2 Si devices

3 X:TiO₂

water splitting

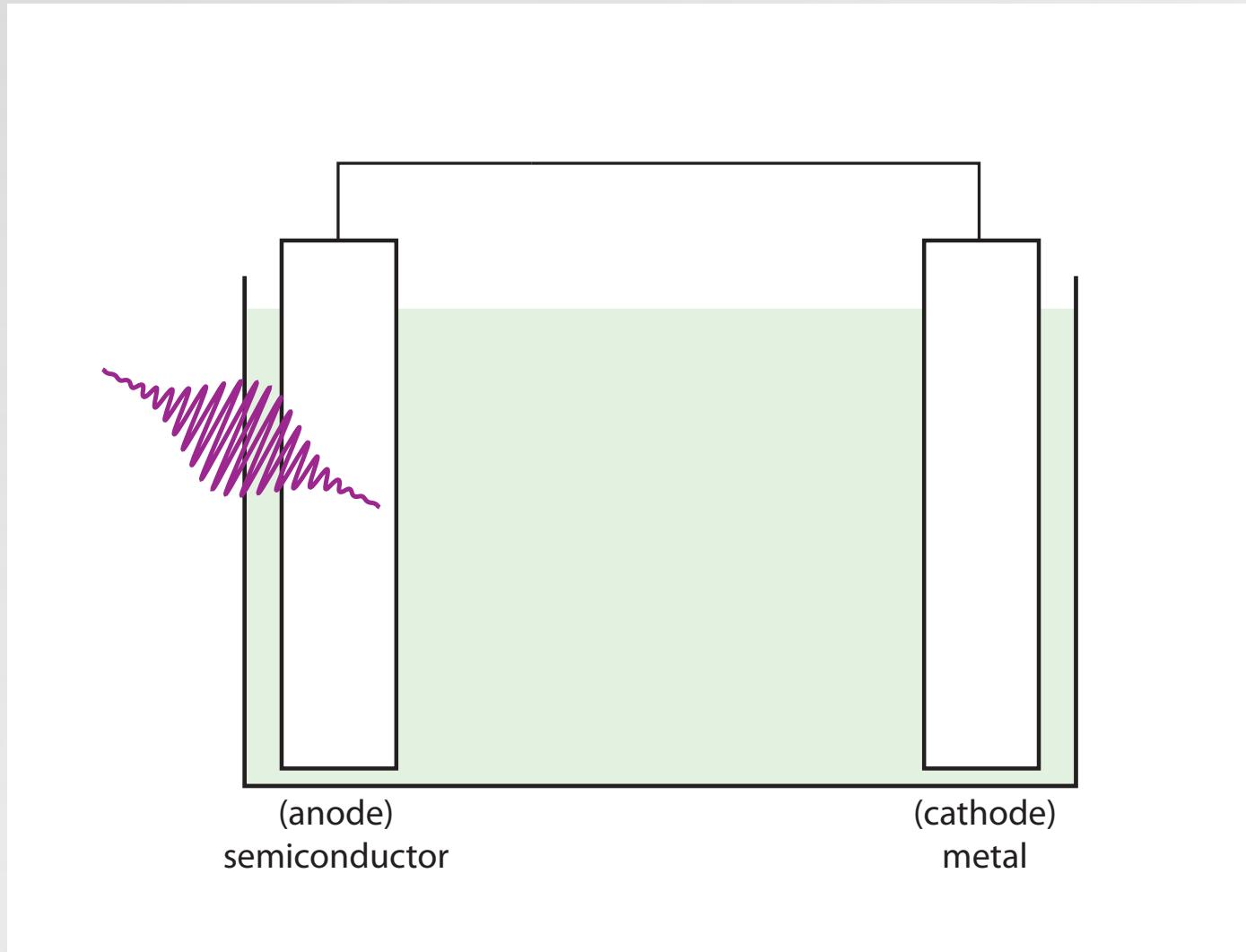


1 intermediate band

2 Si devices

3 $\text{X}:\text{TiO}_2$

water splitting

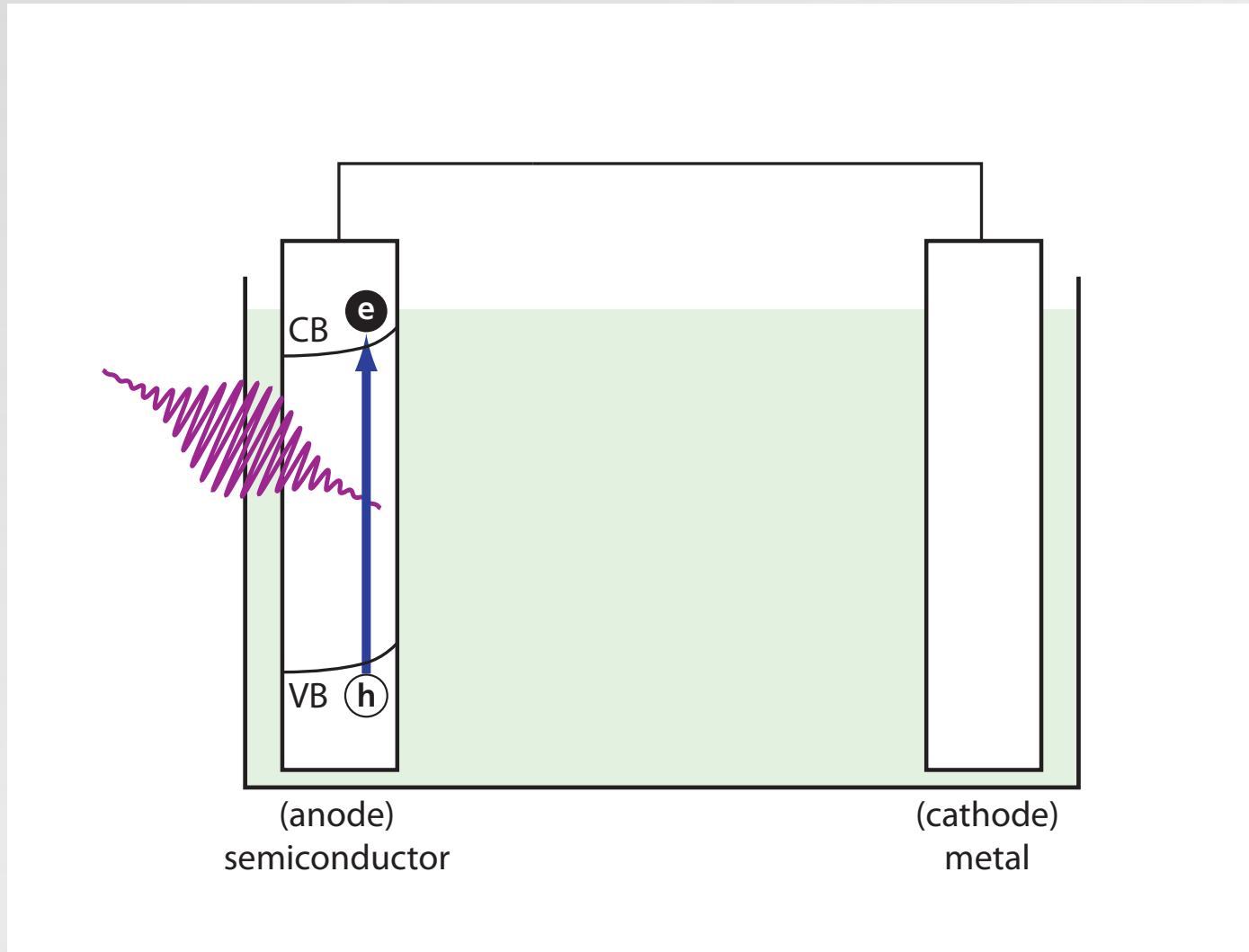


1 intermediate band

2 Si devices

3 $\text{X}:\text{TiO}_2$

water splitting

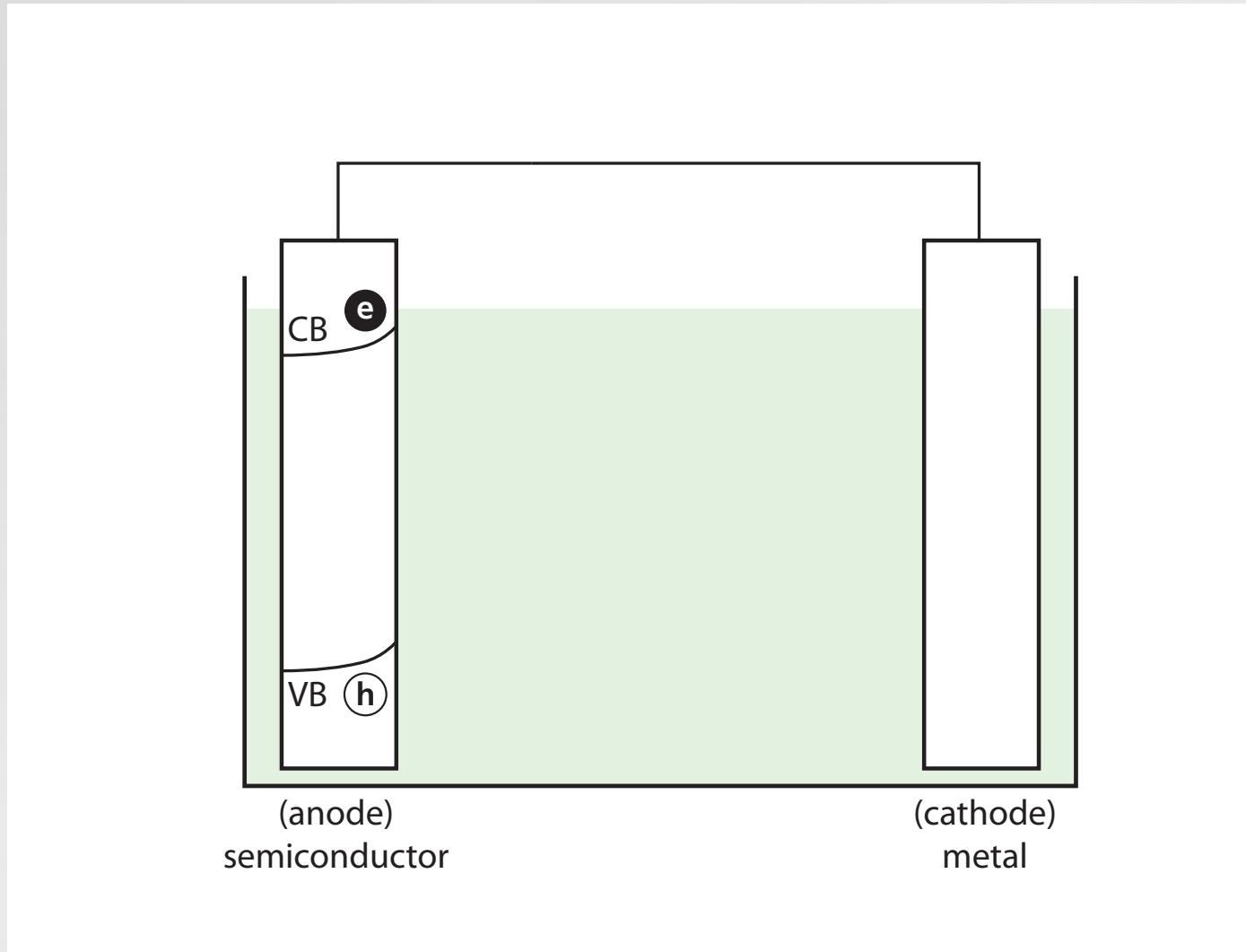


1 intermediate band

2 Si devices

3 $\text{X}:\text{TiO}_2$

water splitting

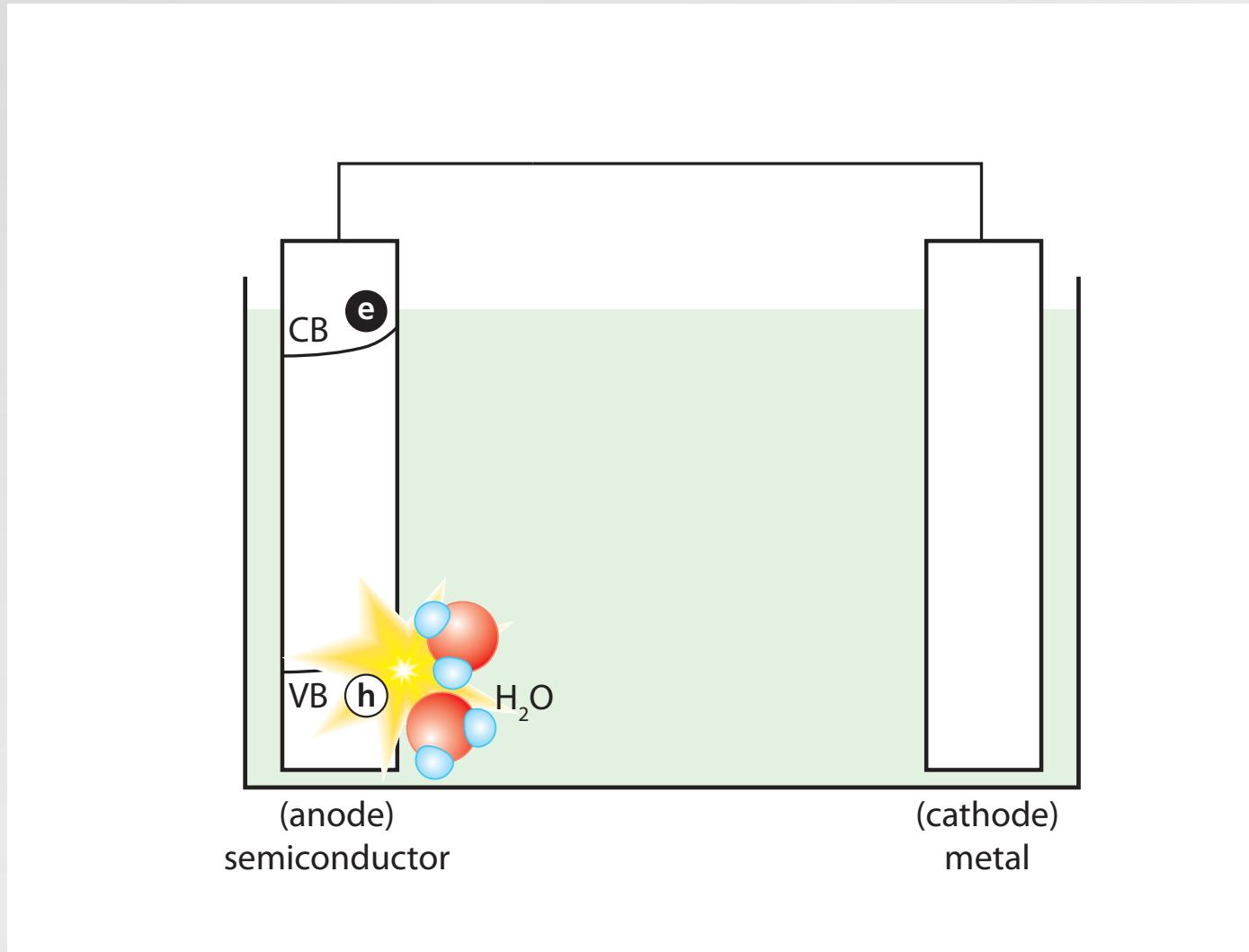


1 intermediate band

2 Si devices

3 $\text{X}:\text{TiO}_2$

water splitting

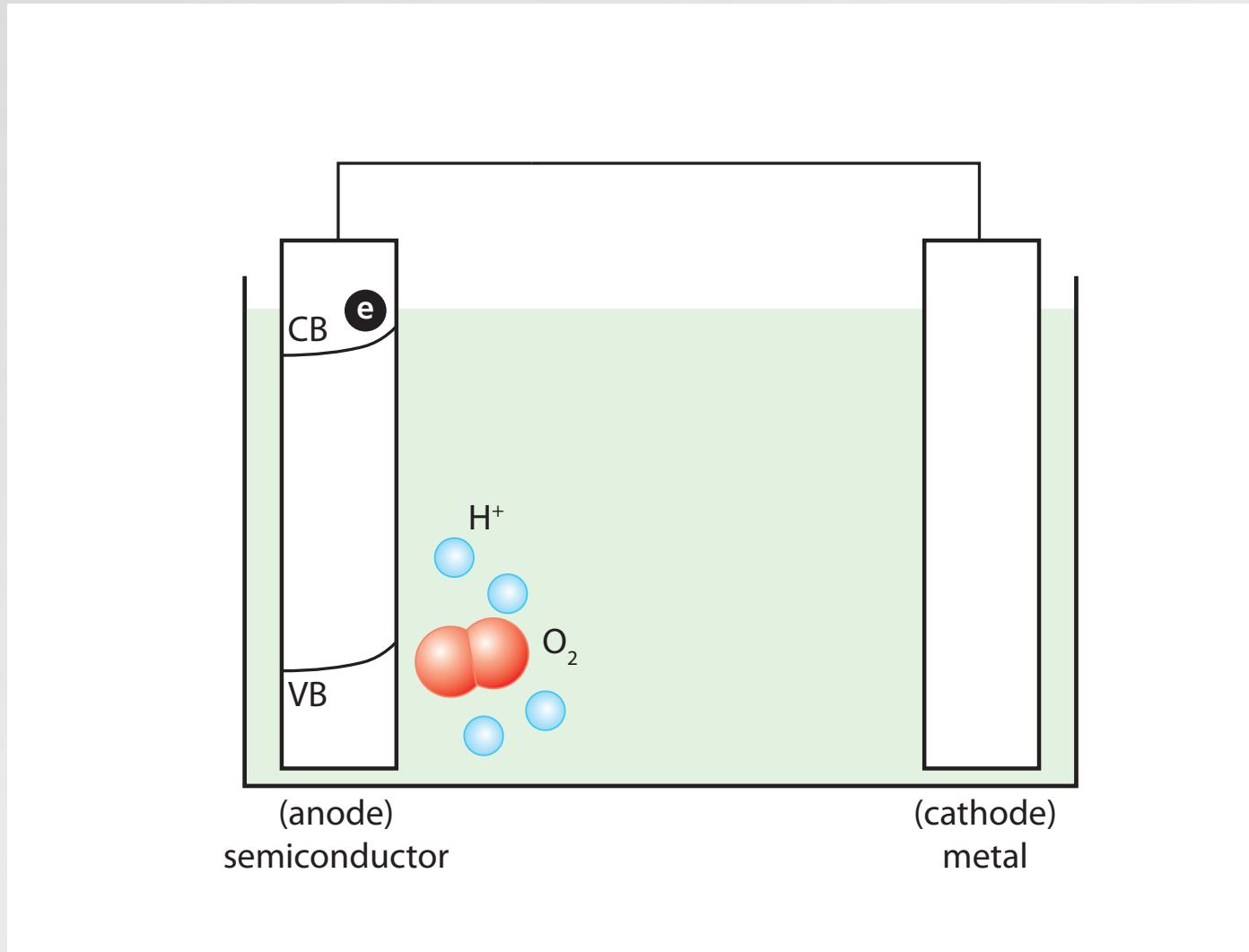


1 intermediate band

2 Si devices

3 X:TiO₂

water splitting

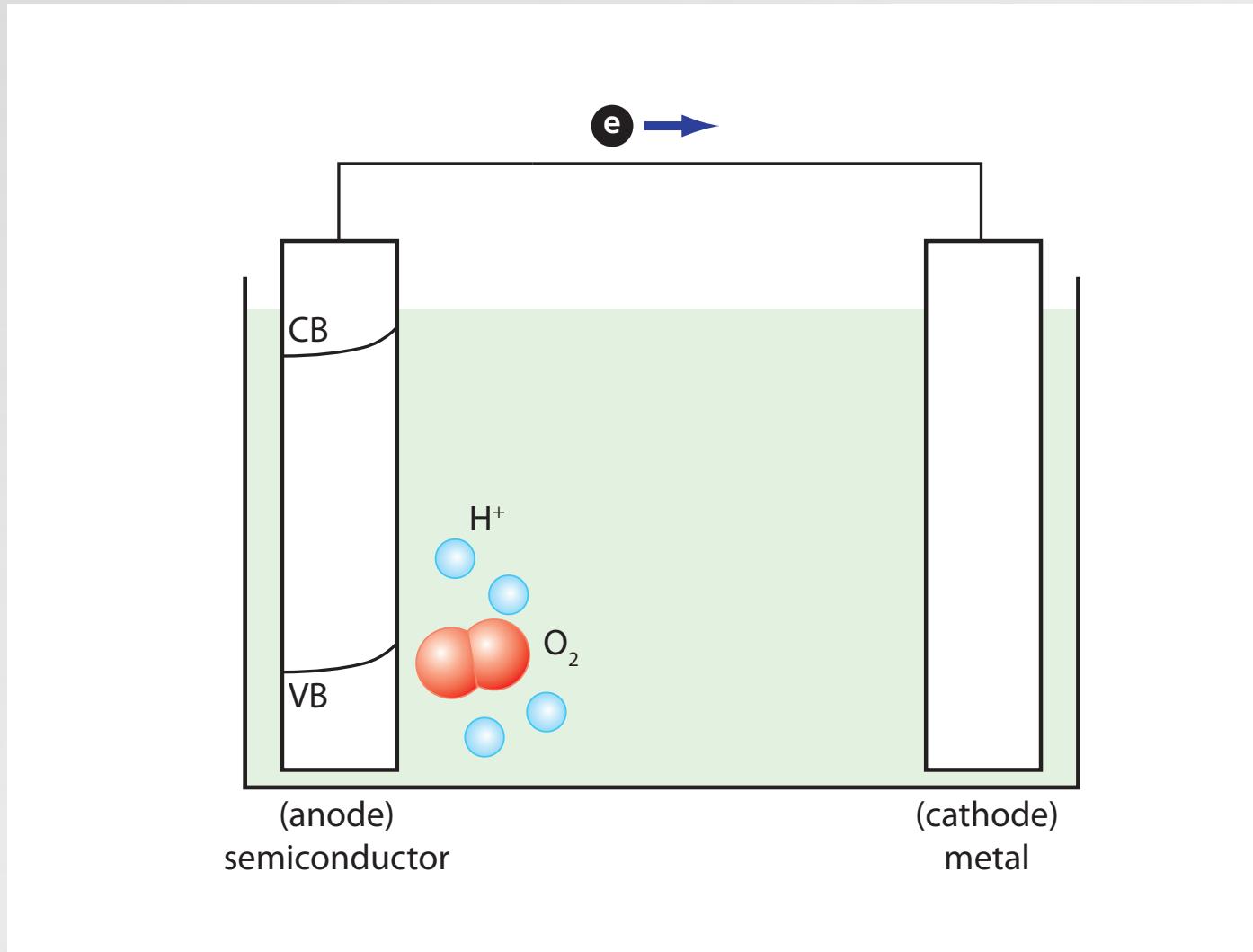


1 intermediate band

2 Si devices

3 $X:\text{TiO}_2$

water splitting

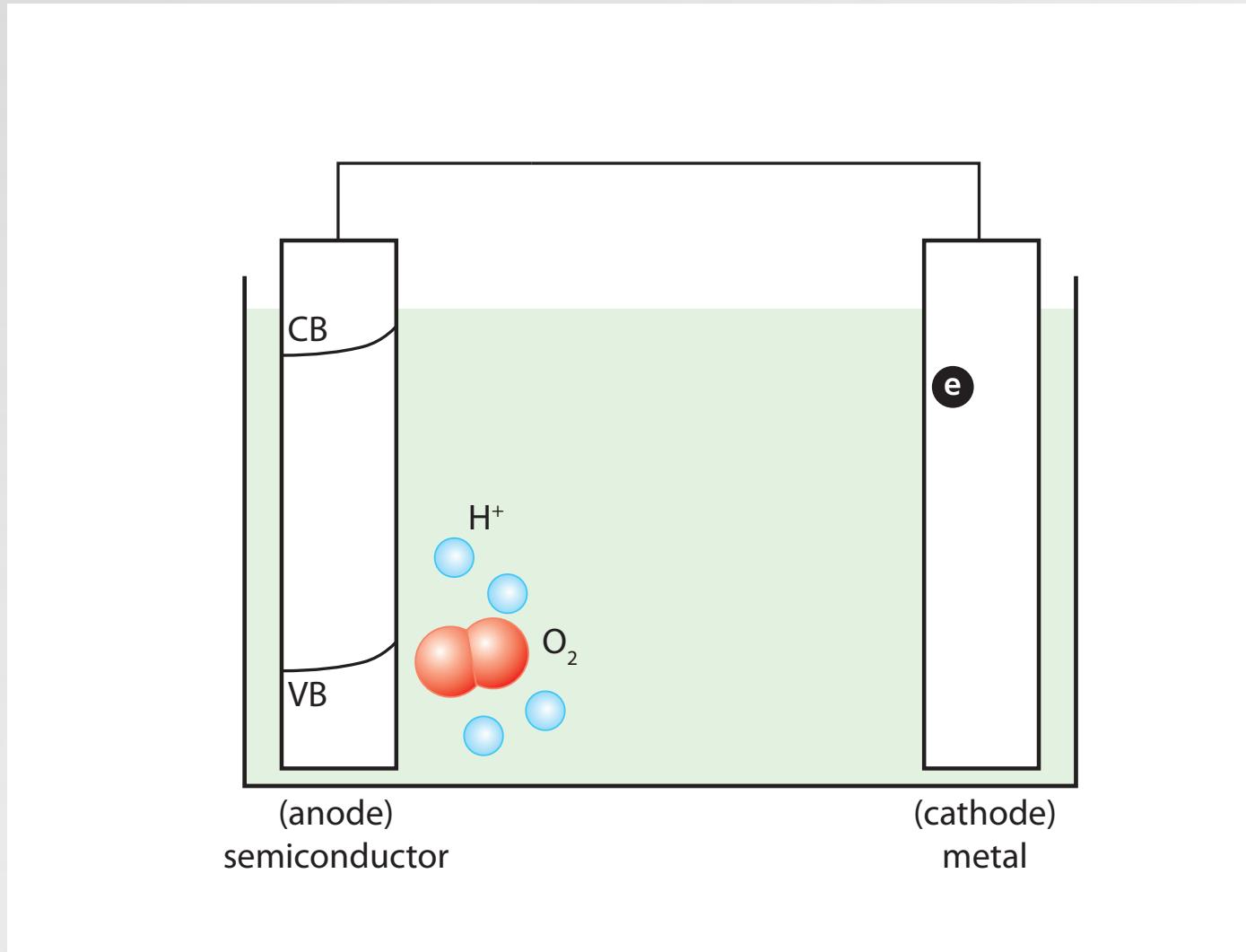


1 intermediate band

2 Si devices

3 $X:\text{TiO}_2$

water splitting

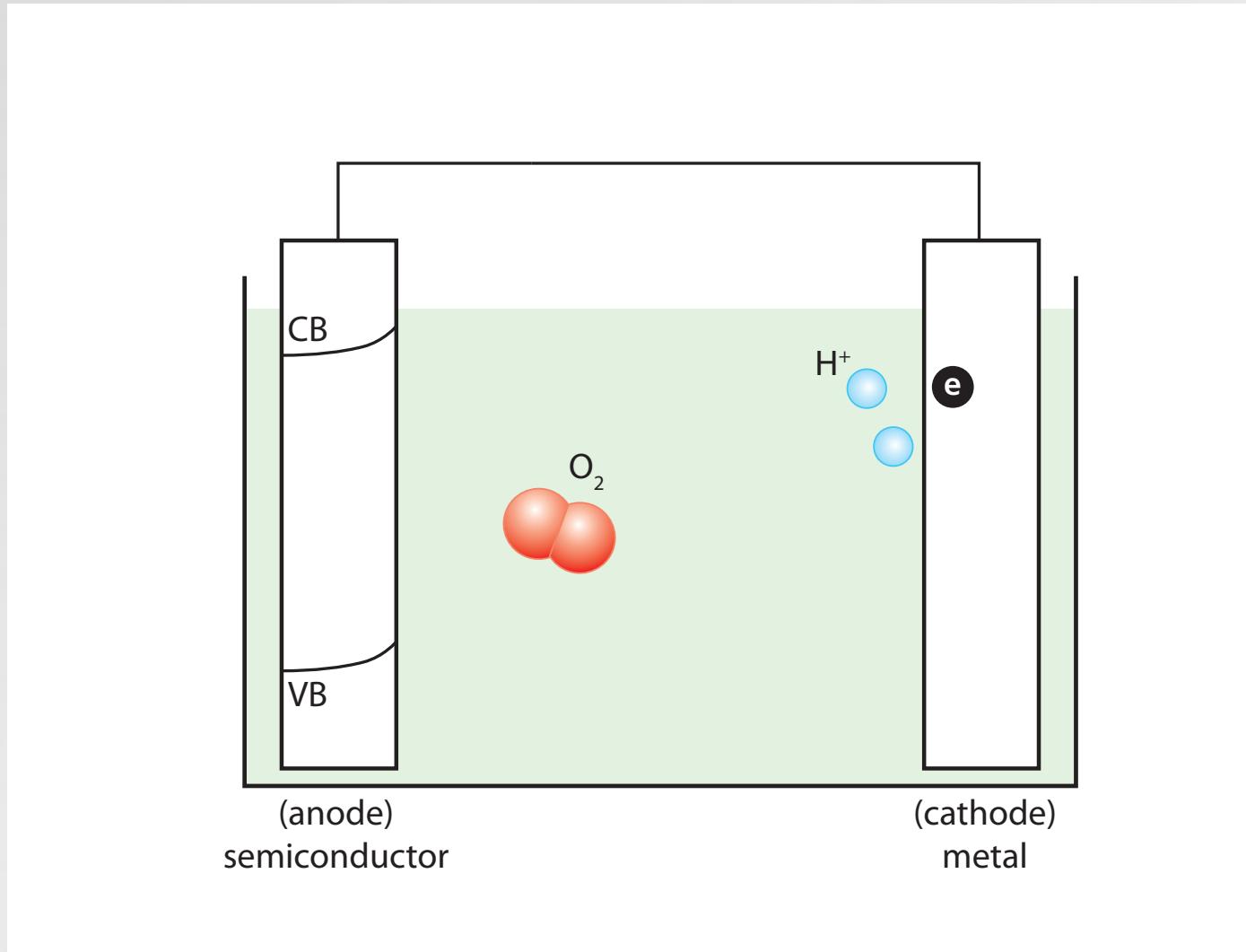


1 intermediate band

2 Si devices

3 $X:\text{TiO}_2$

water splitting

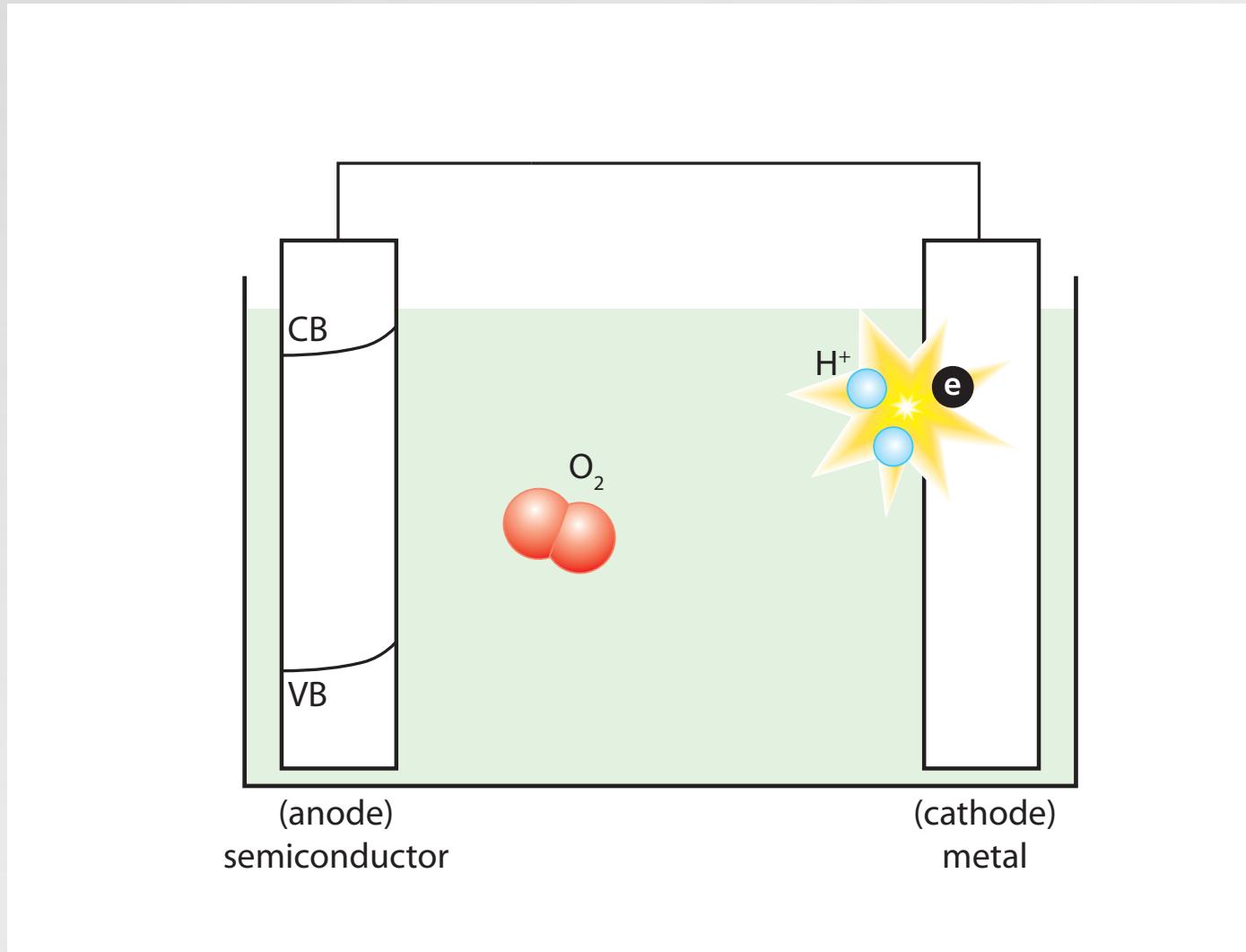


1 intermediate band

2 Si devices

3 X:TiO₂

water splitting

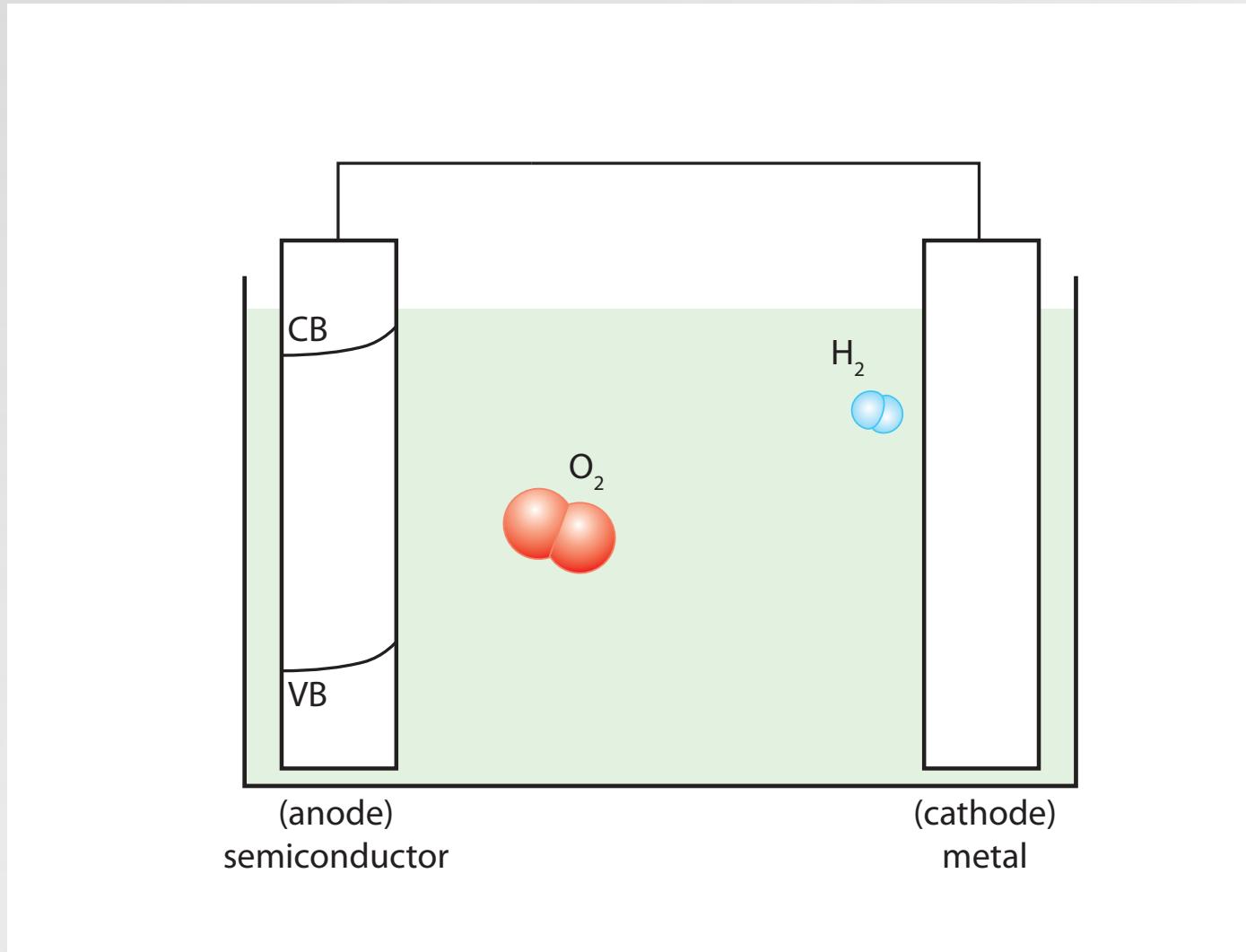


1 intermediate band

2 Si devices

3 $X:\text{TiO}_2$

water splitting

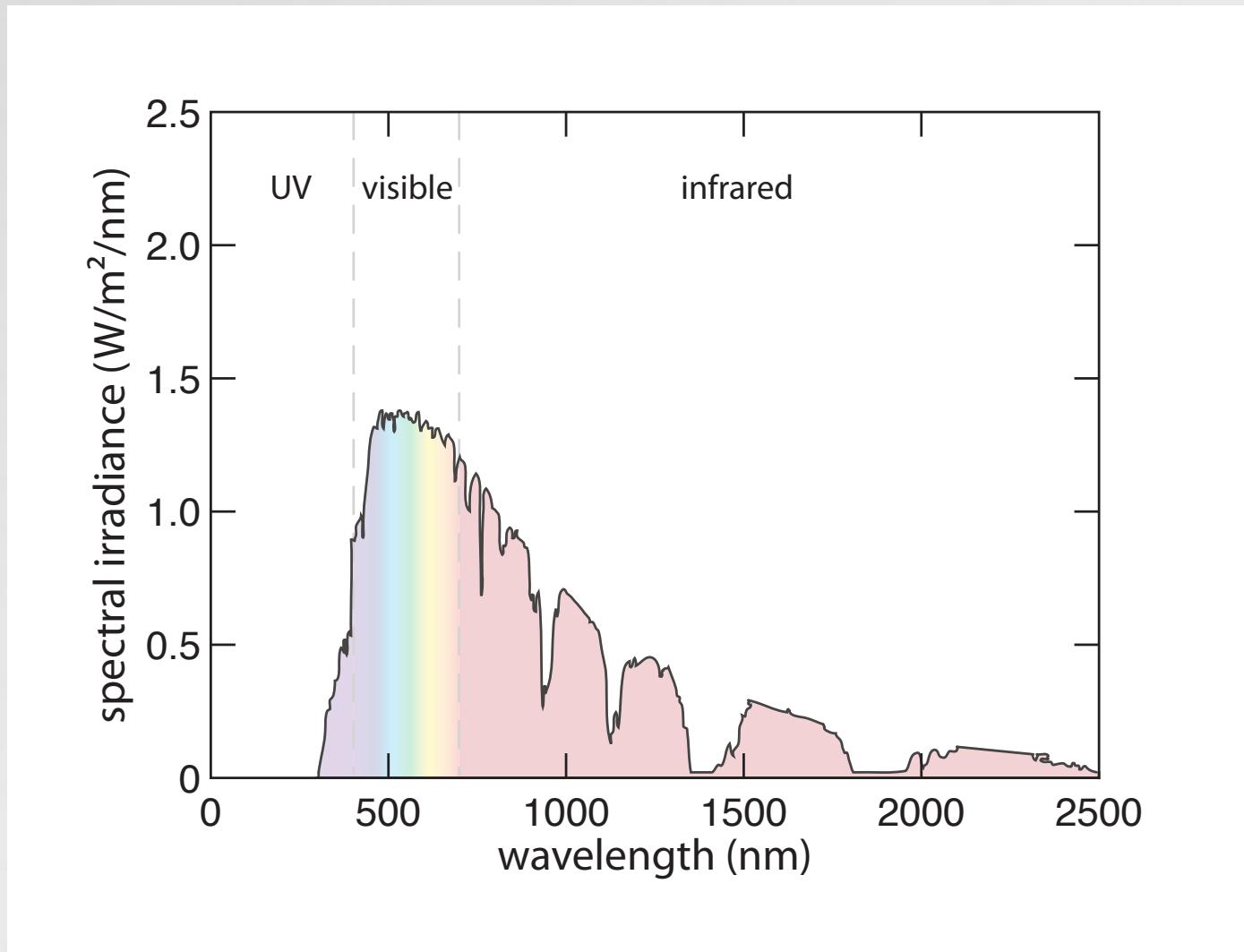


1 intermediate band

2 Si devices

3 $X:\text{TiO}_2$

solar radiation spectrum

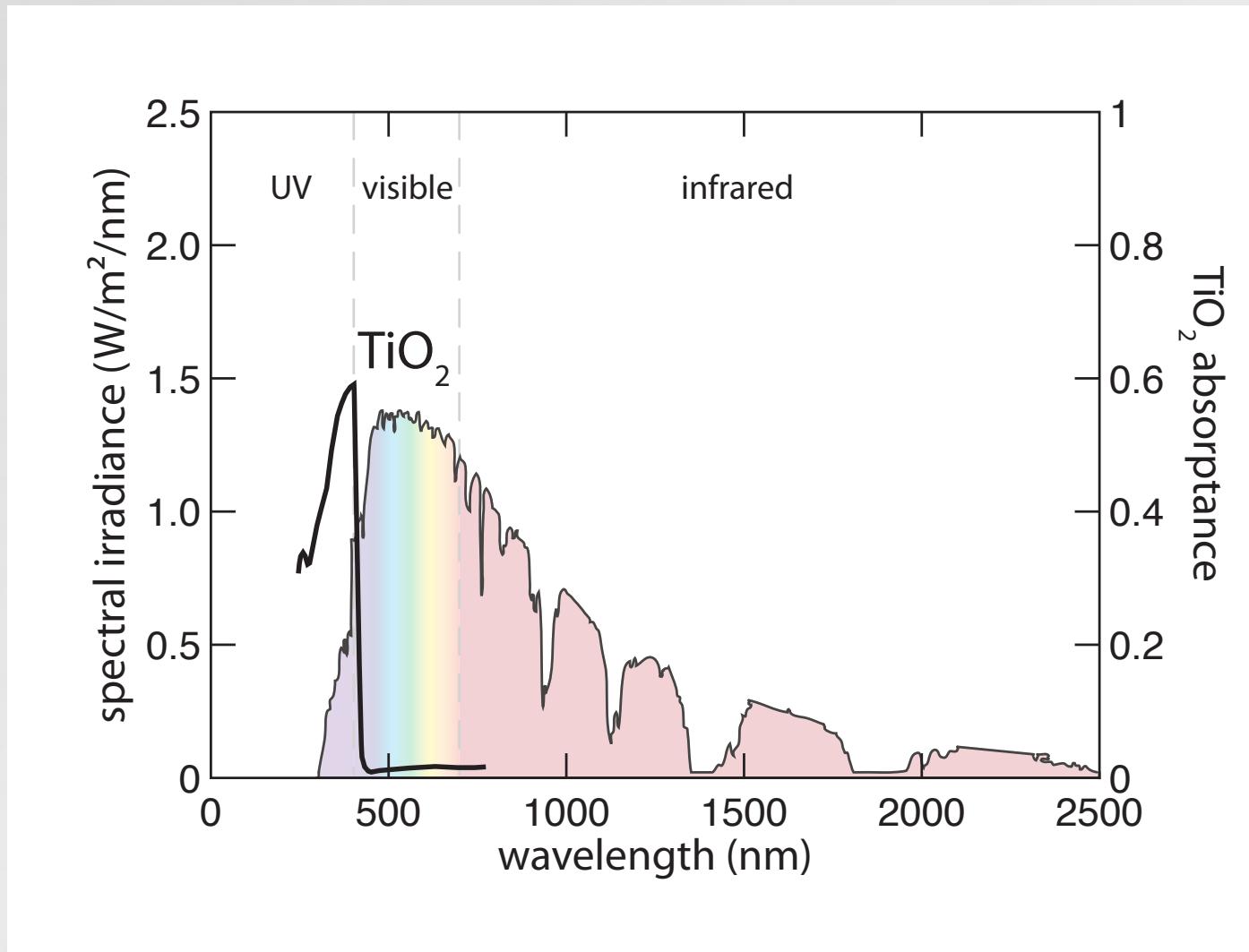


1 intermediate band

2 Si devices

3 X:TiO₂

solar radiation spectrum

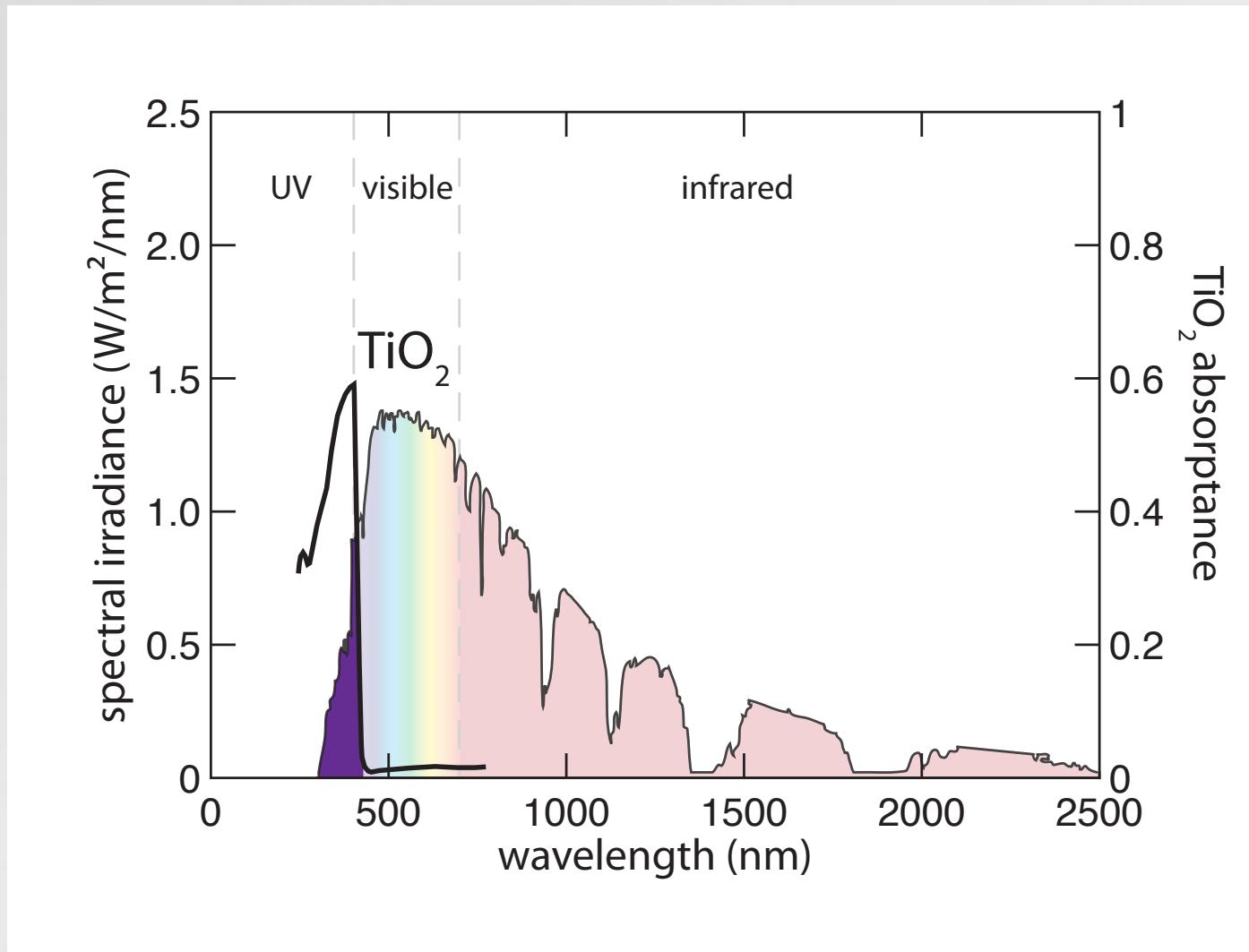


1 intermediate band

2 Si devices

3 X: TiO_2

solar radiation spectrum



1 intermediate band

2 Si devices

3 X: TiO_2



increase efficiency by:

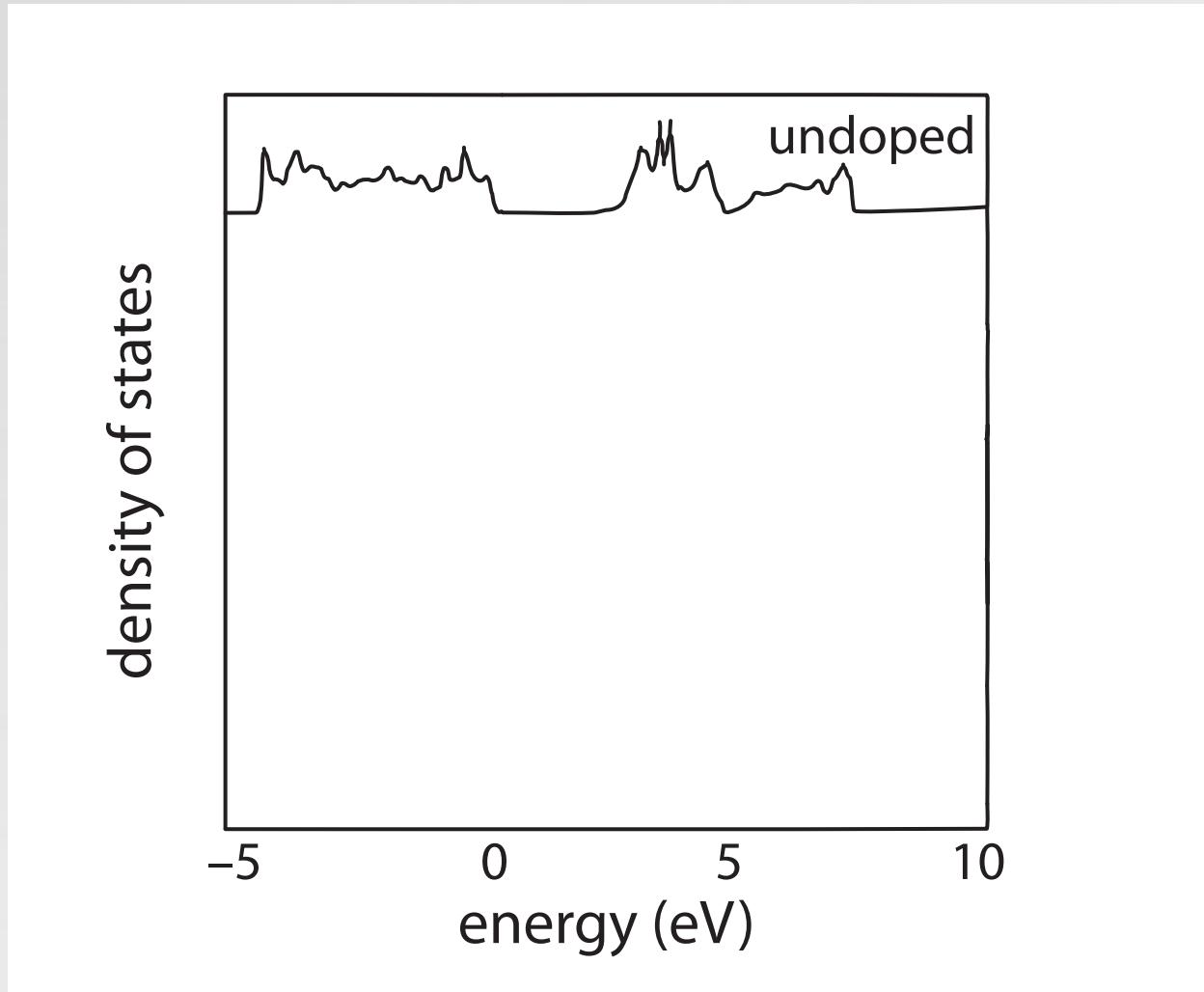
- increasing surface area
- shifting band edge

1 intermediate band

2 Si devices

3 X:TiO₂

TiO_2 density of states



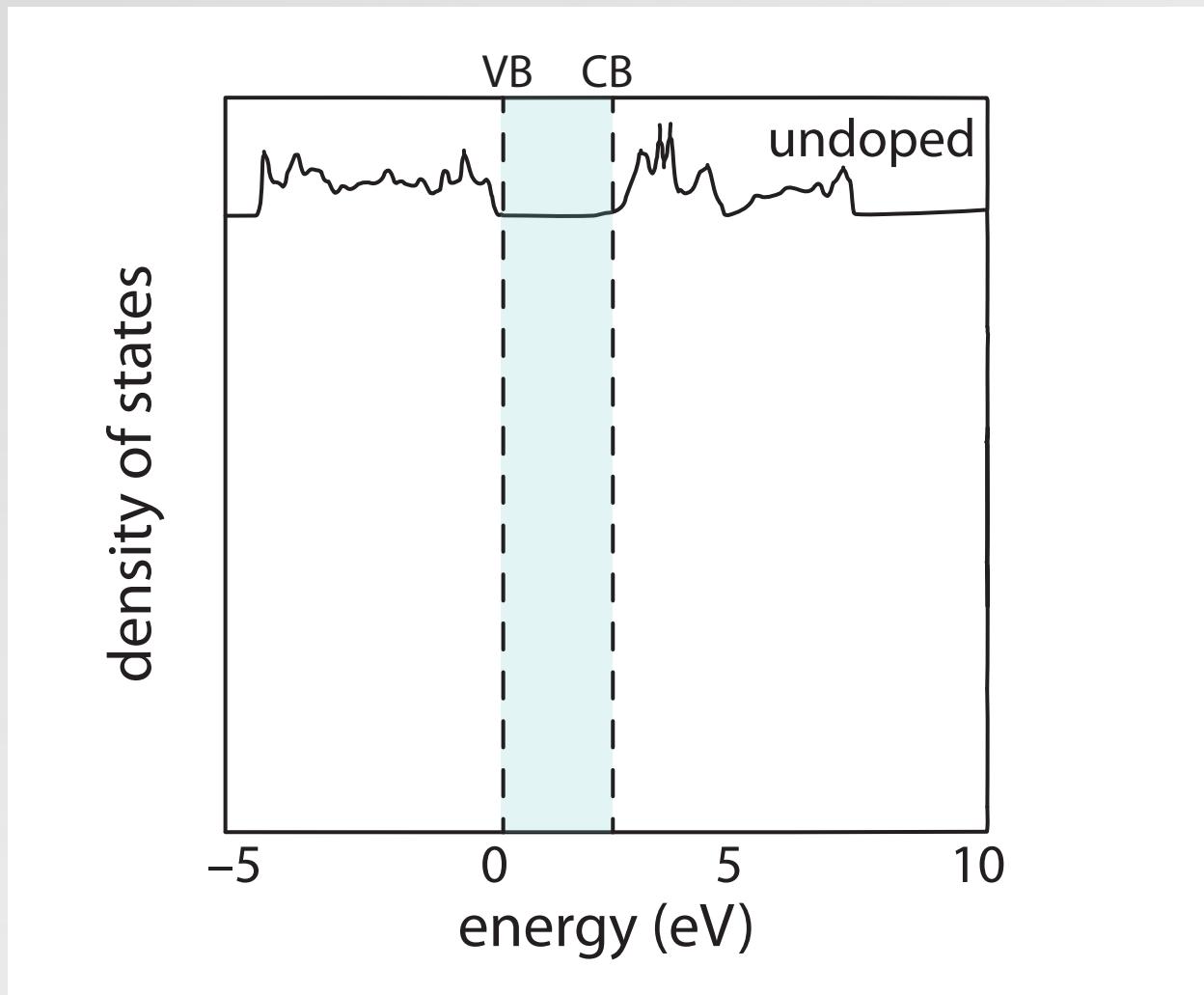
Asahi et al., Science (2001)

1 intermediate band

2 Si devices

3 X: TiO_2

need to create band(s) in gap



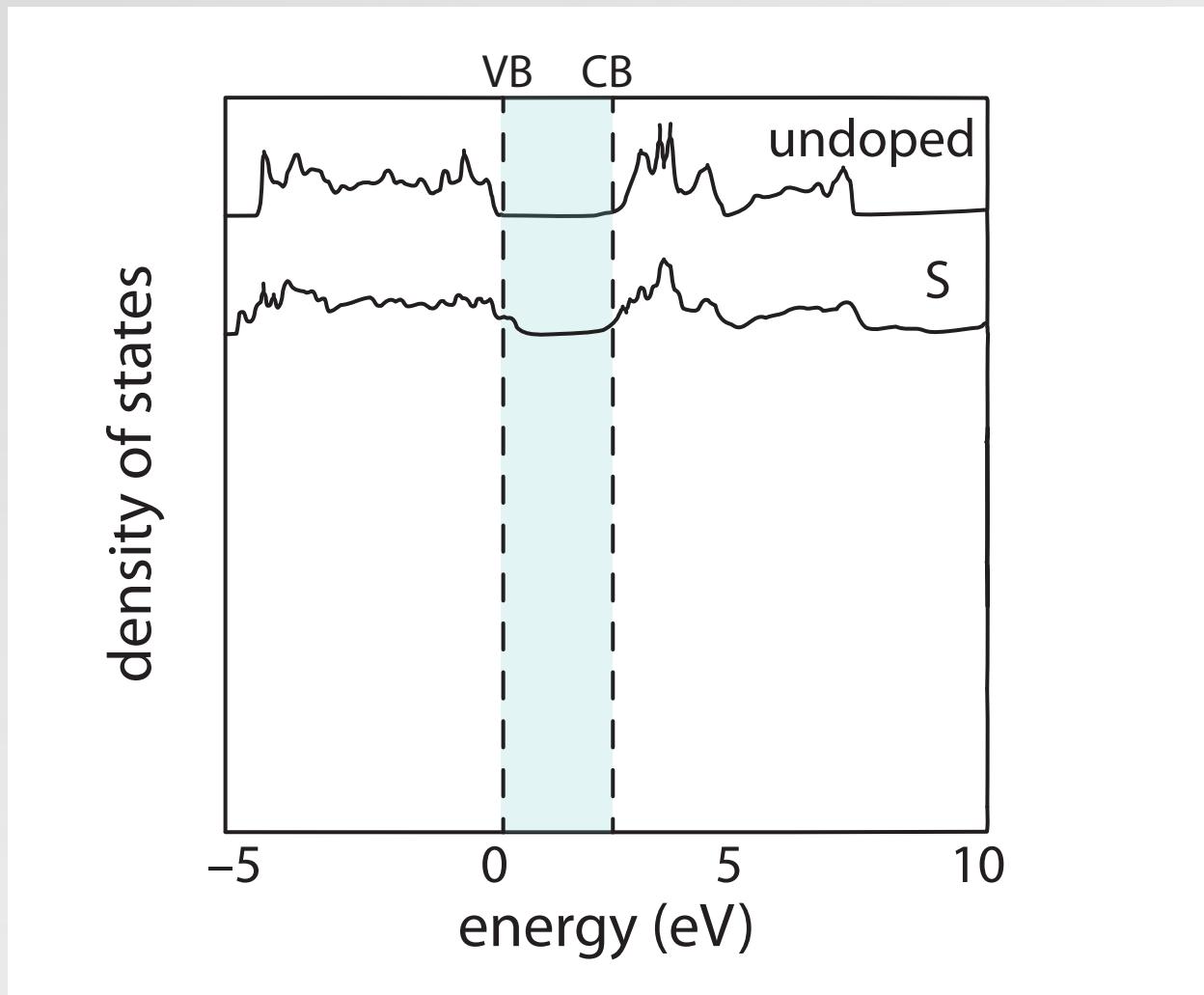
Asahi et al., Science (2001)

1 intermediate band

2 Si devices

3 X:TiO₂

need to create band(s) in gap



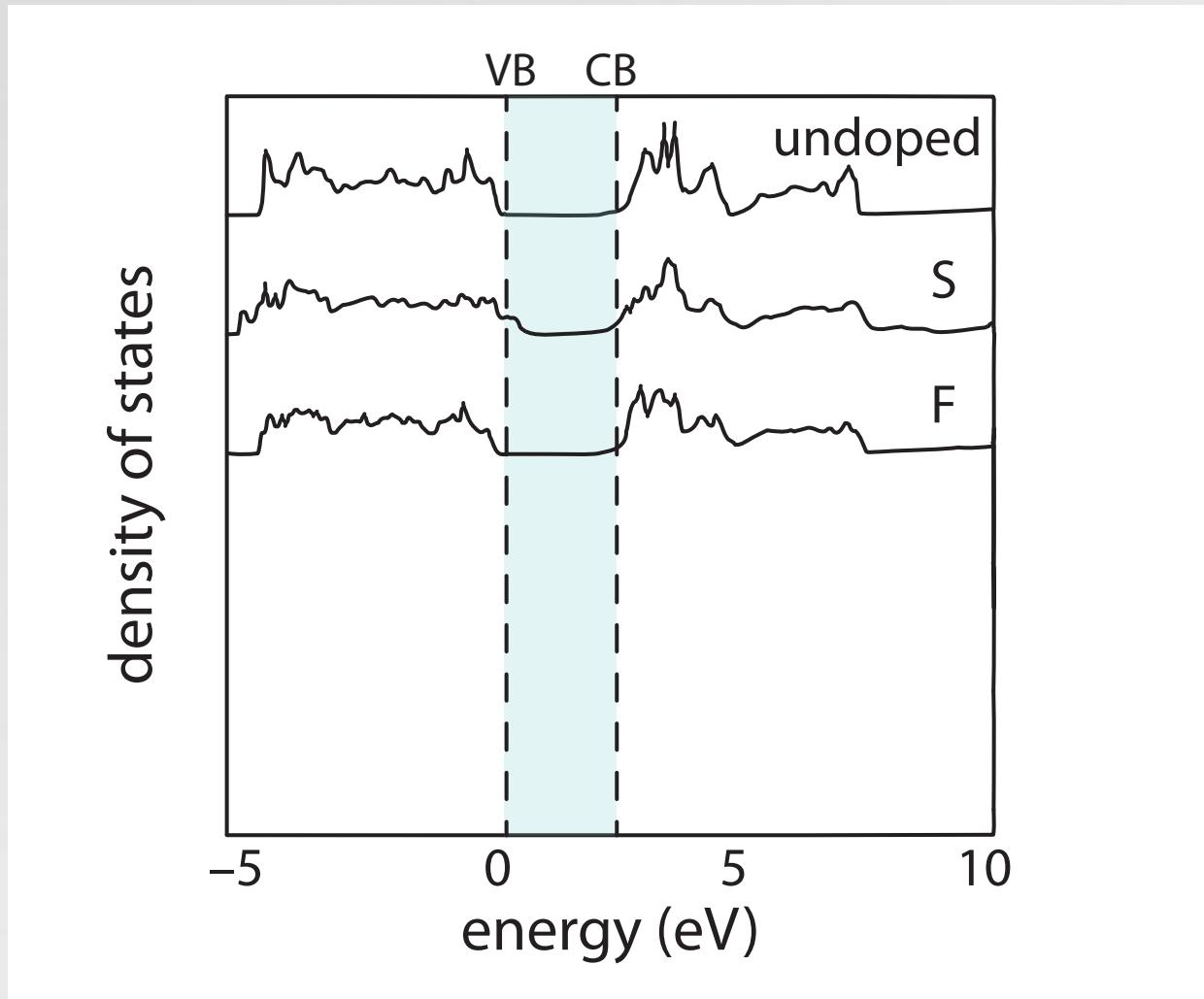
Asahi et al., Science (2001)

1 intermediate band

2 Si devices

3 X:TiO₂

need to create band(s) in gap



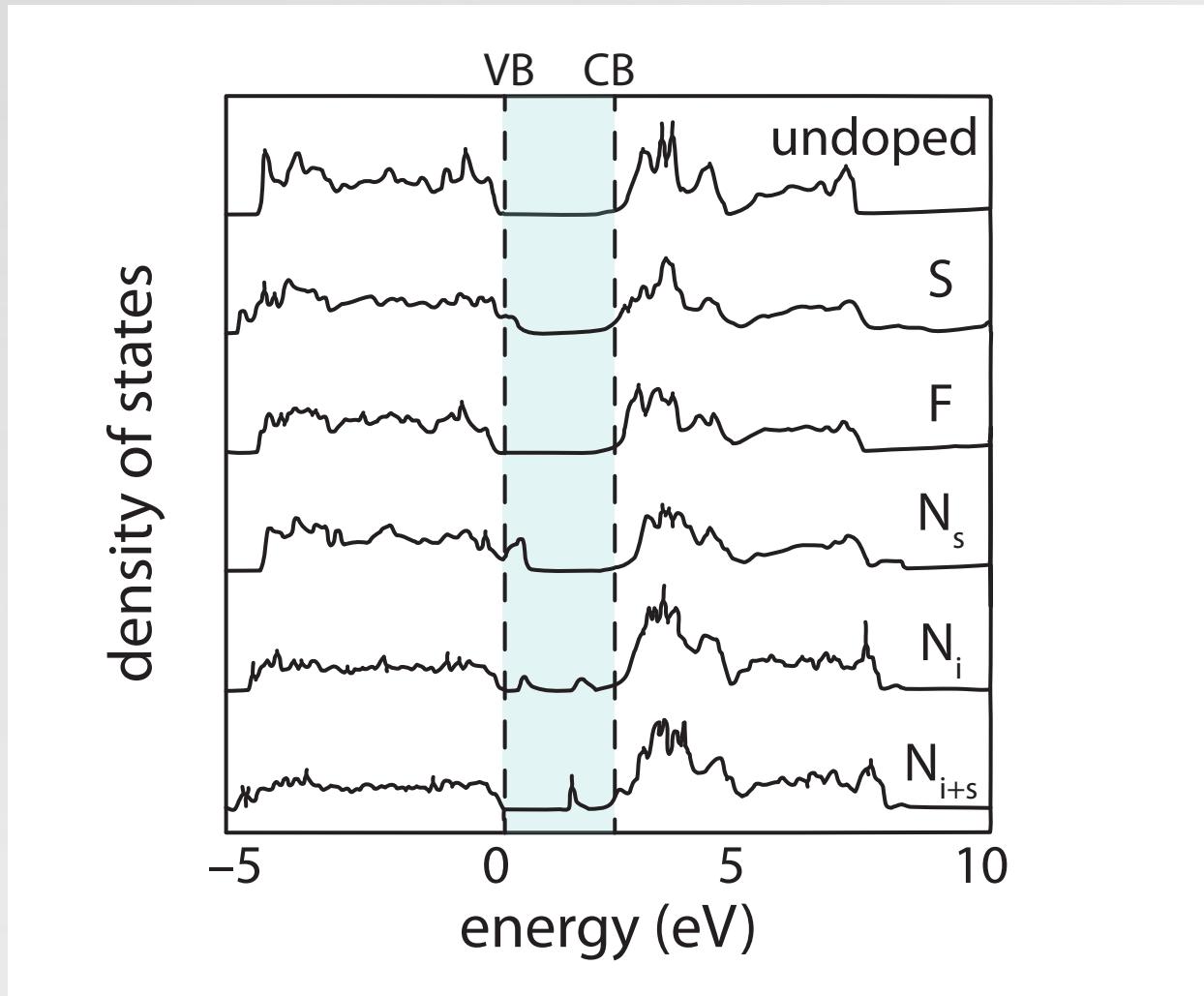
Asahi et al., Science (2001)

1 intermediate band

2 Si devices

3 X:TiO₂

need to create band(s) in gap



Asahi et al., Science (2001)

1 intermediate band

2 Si devices

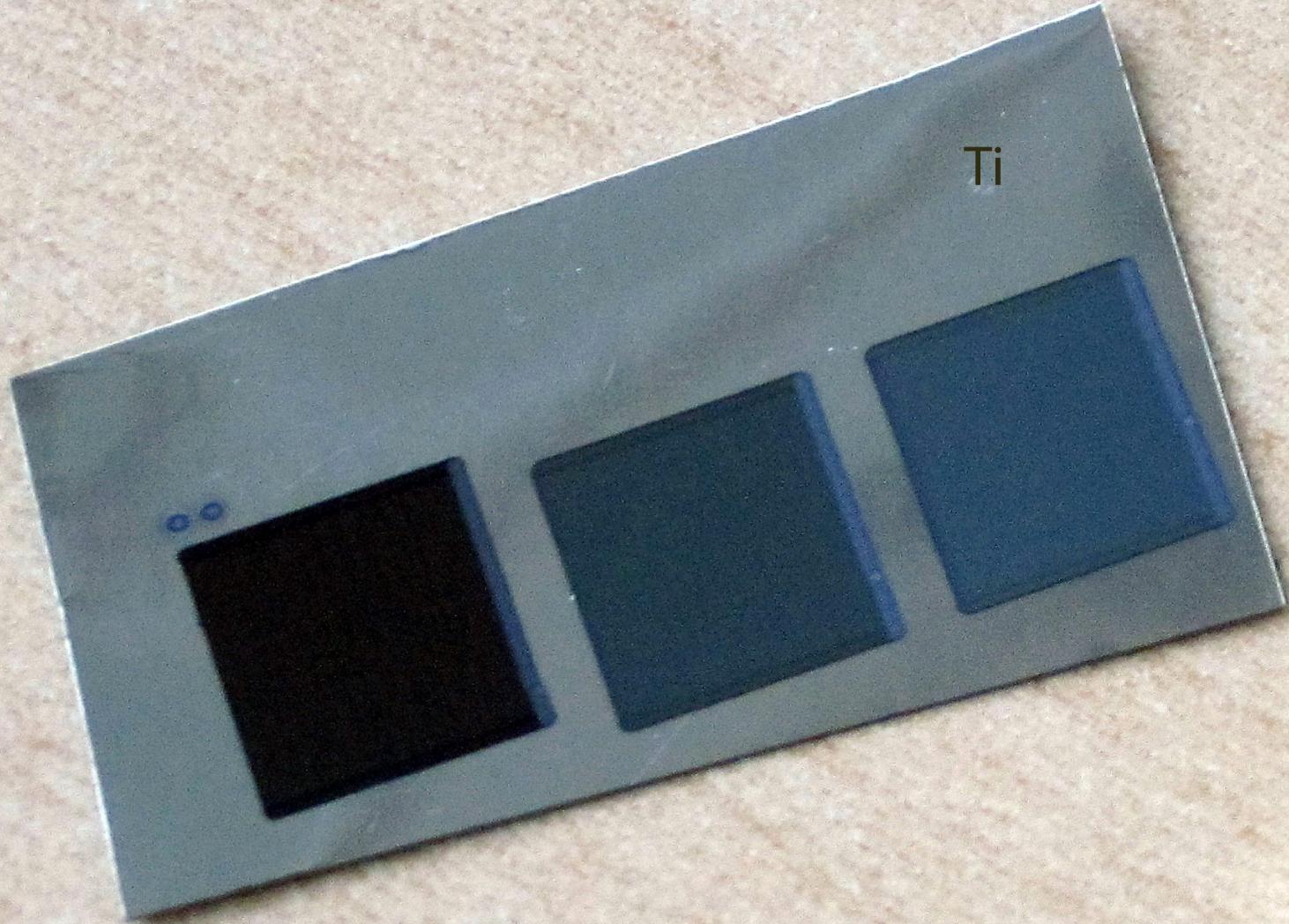
3 $\text{X}:\text{TiO}_2$

structuring TiO_2 in N_2 doesn't work

1 intermediate band

2 Si devices

3 X: TiO_2

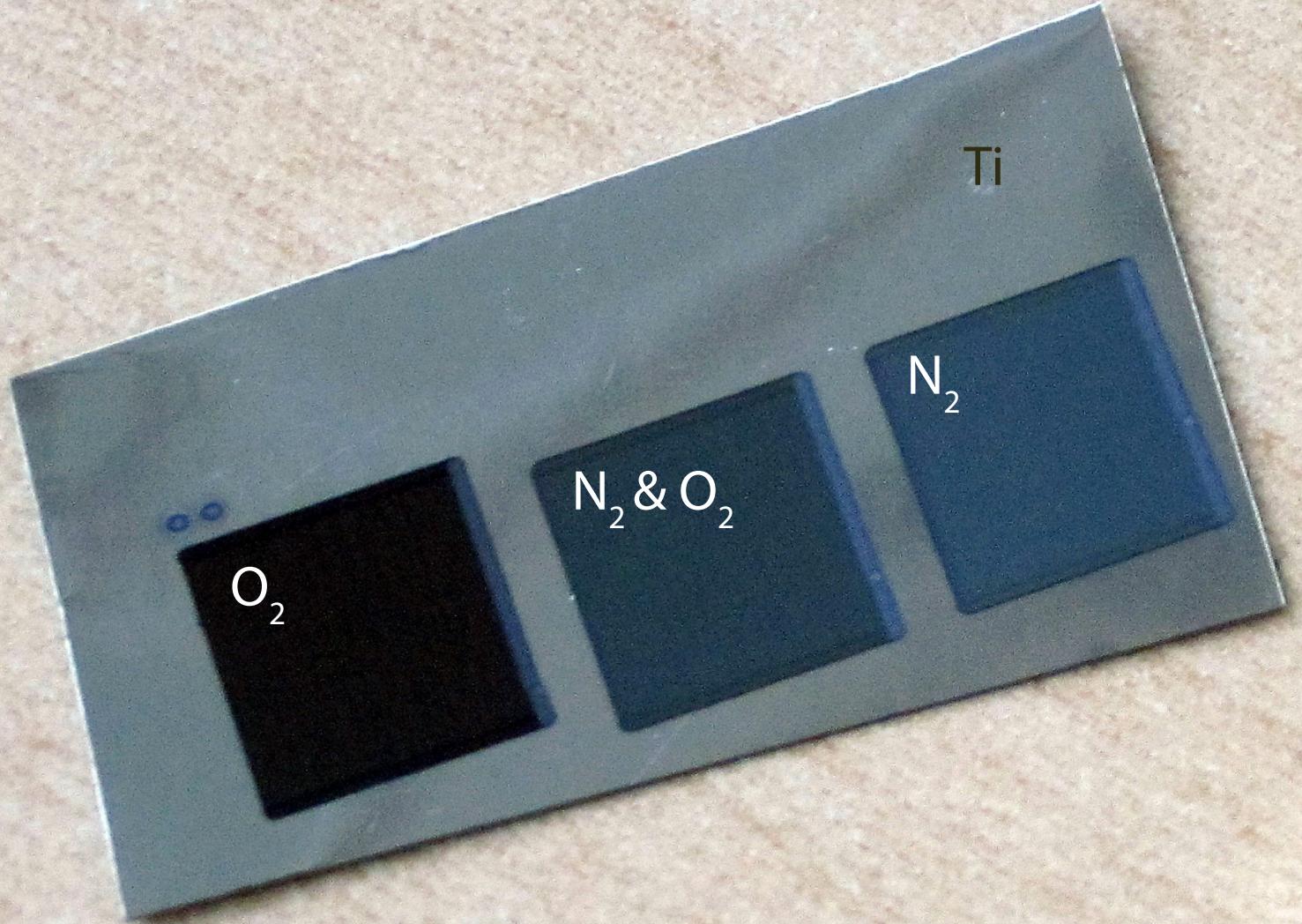


1 intermediate band

2 Si devices

3 X:TiO₂



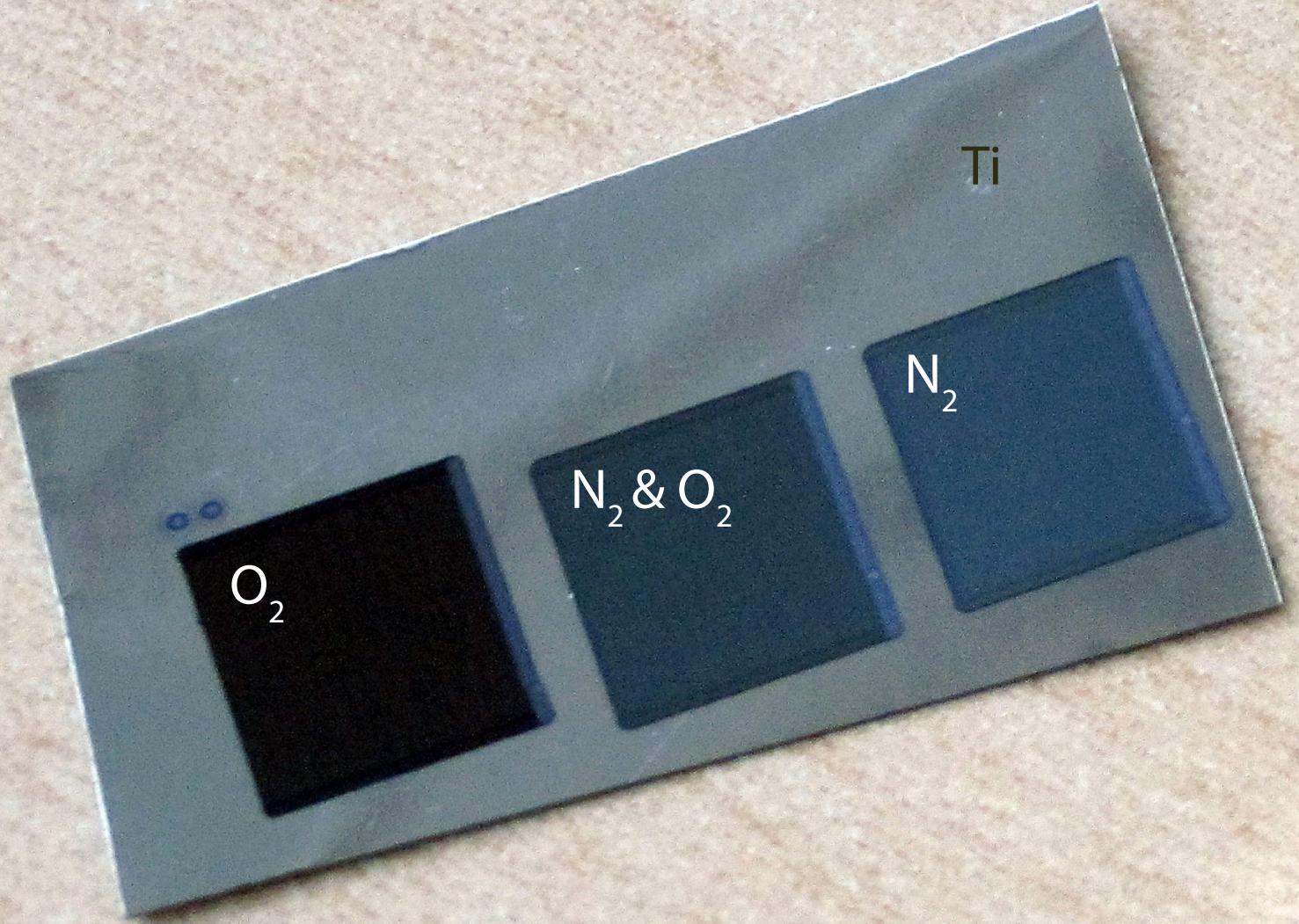


1 intermediate band

2 Si devices

3 X:TiO₂





50 pulses @ 2.5 kJ/m²

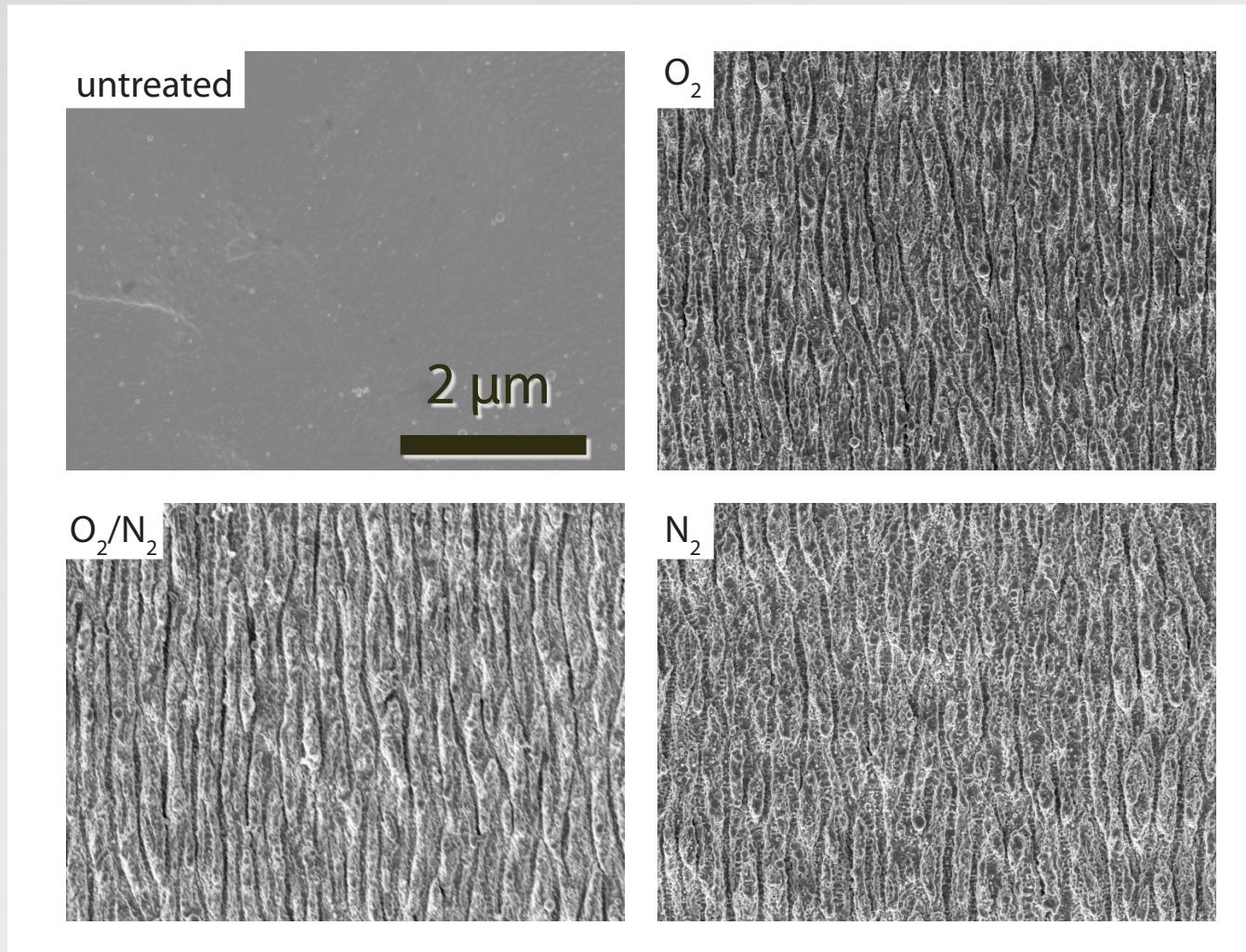
1 intermediate band

2 Si devices

3 X:TiO₂



50 pulses @ 2.5 kJ/m²

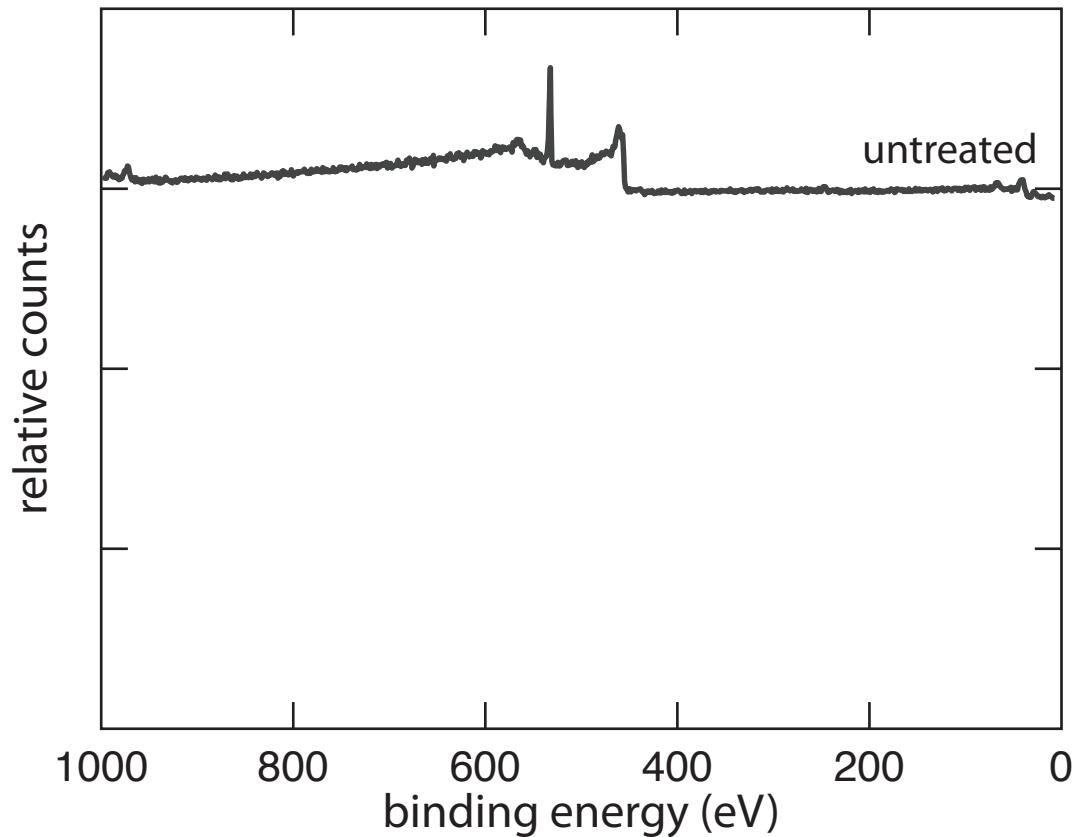


1 intermediate band

2 Si devices

3 X:TiO₂

X-ray photoelectron spectroscopy

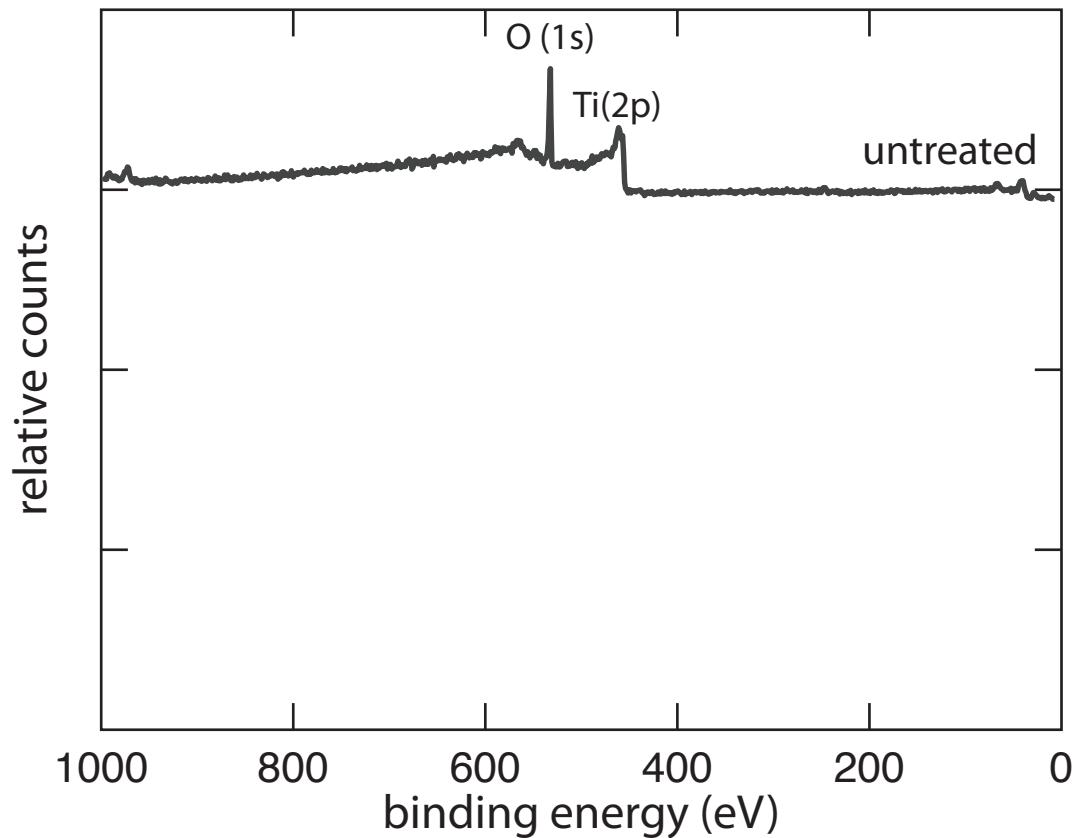


1 intermediate band

2 Si devices

3 $\text{X}:\text{TiO}_2$

X-ray photoelectron spectroscopy

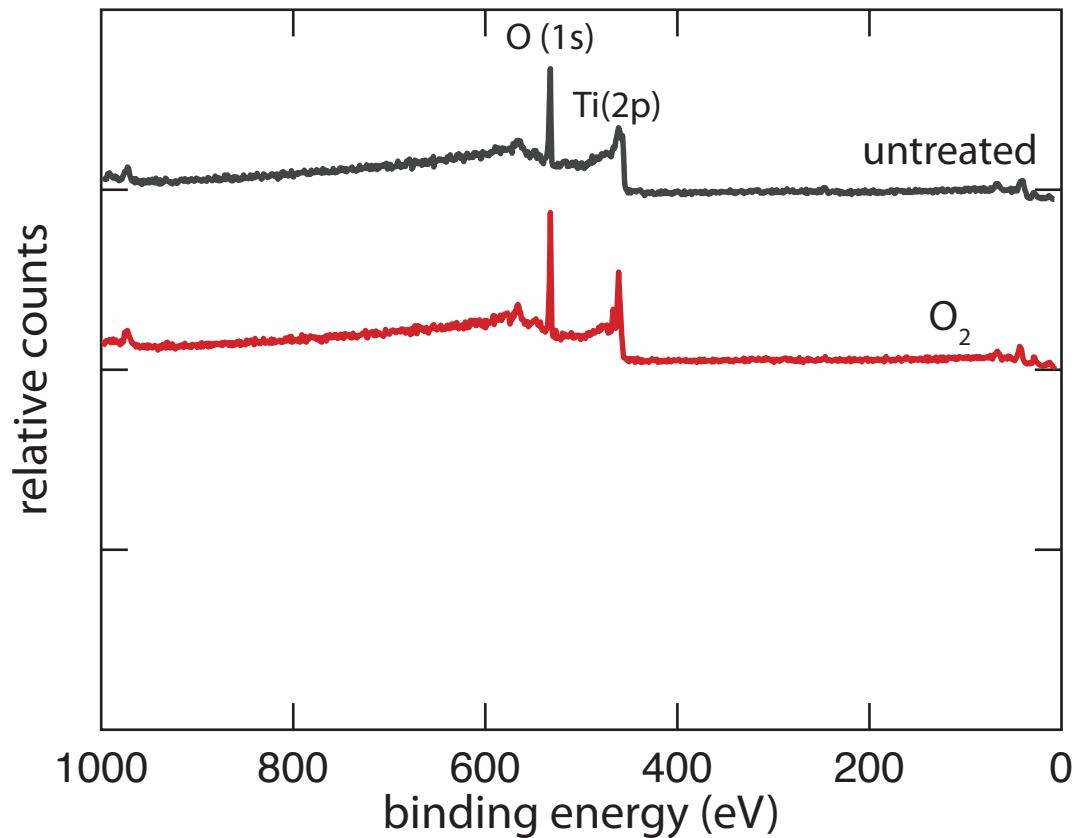


1 intermediate band

2 Si devices

3 $\text{X}:\text{TiO}_2$

X-ray photoelectron spectroscopy

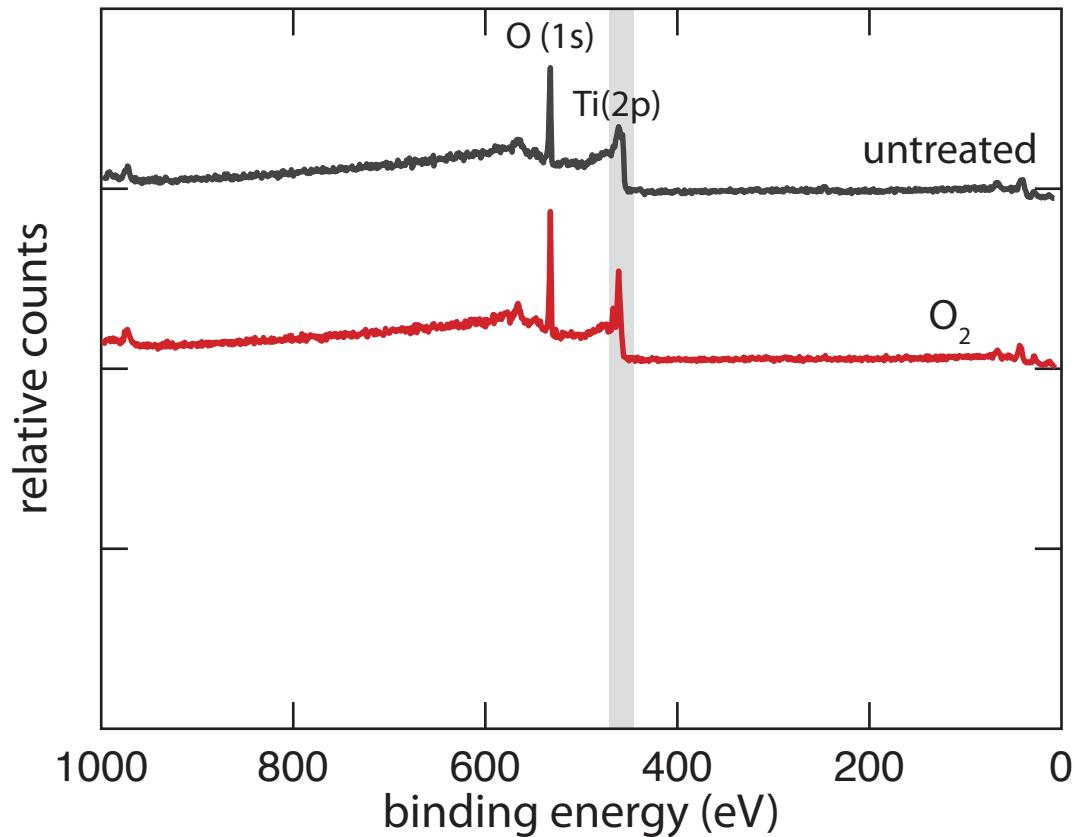


1 intermediate band

2 Si devices

3 X:TiO₂

X-ray photoelectron spectroscopy

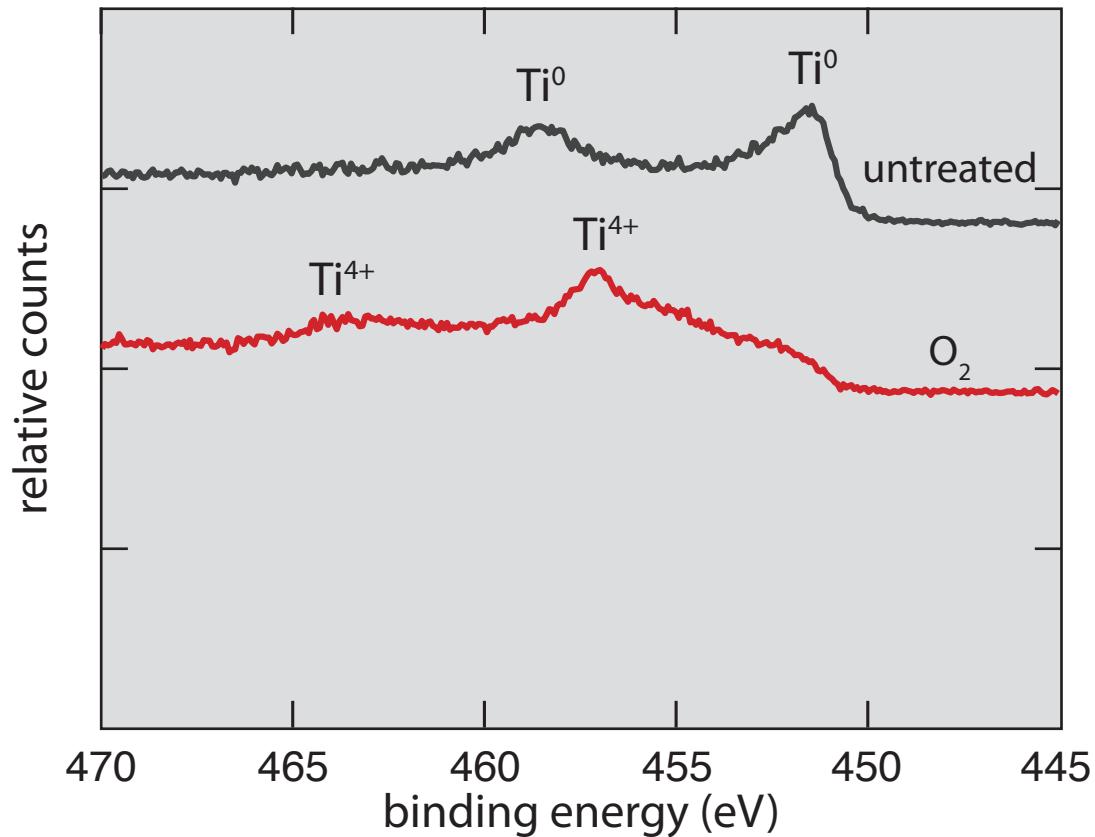


1 intermediate band

2 Si devices

3 X:TiO₂

oxygen is incorporated!

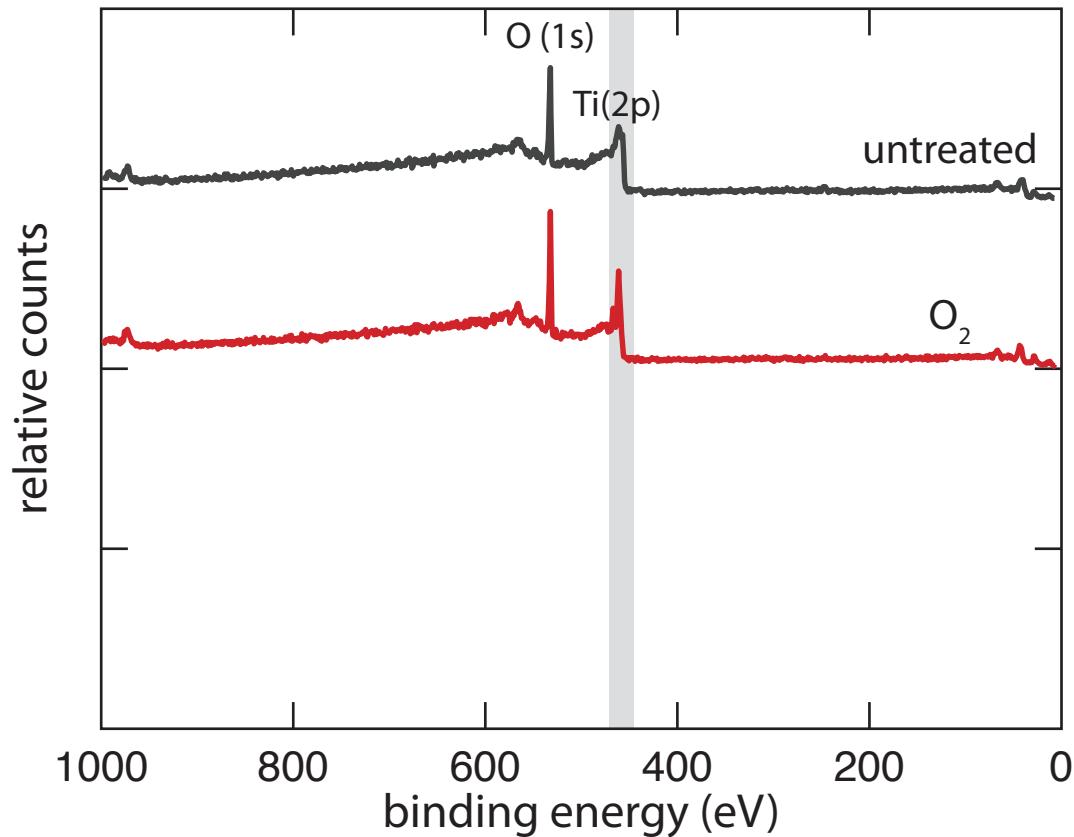


1 intermediate band

2 Si devices

3 $\text{X}:\text{TiO}_2$

oxygen is incorporated!

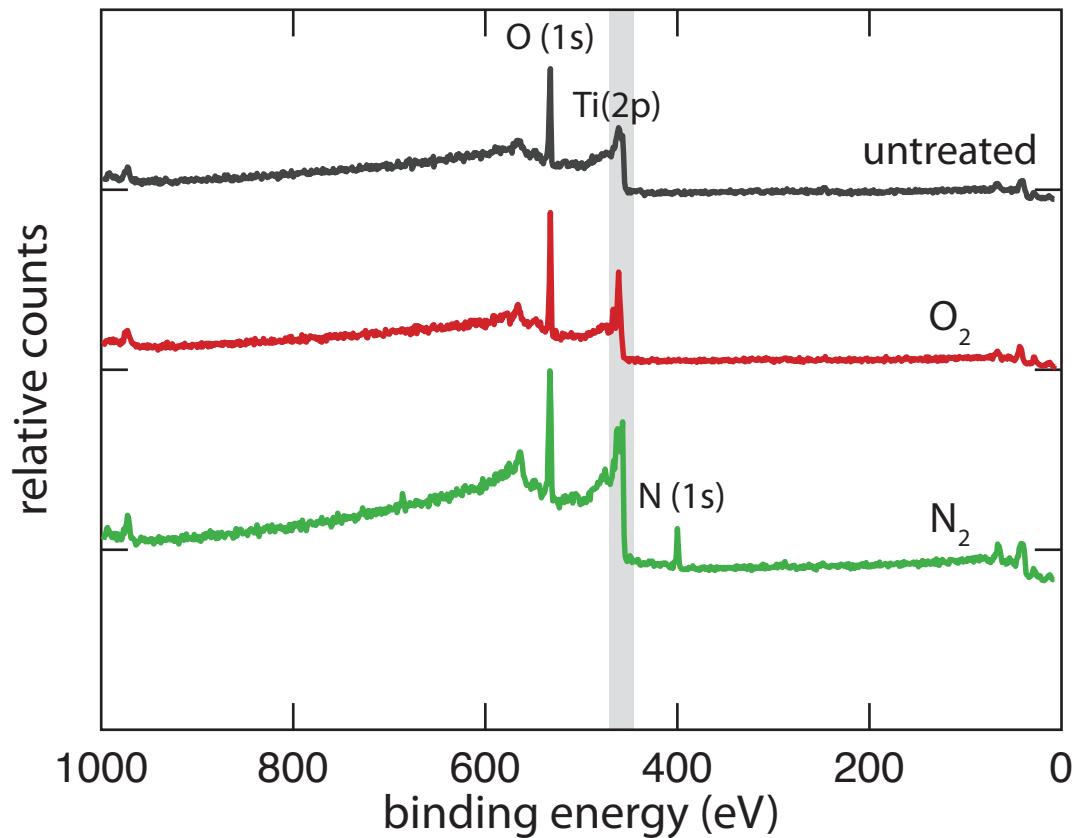


1 intermediate band

2 Si devices

3 X:TiO₂

nitrogen peak appears...

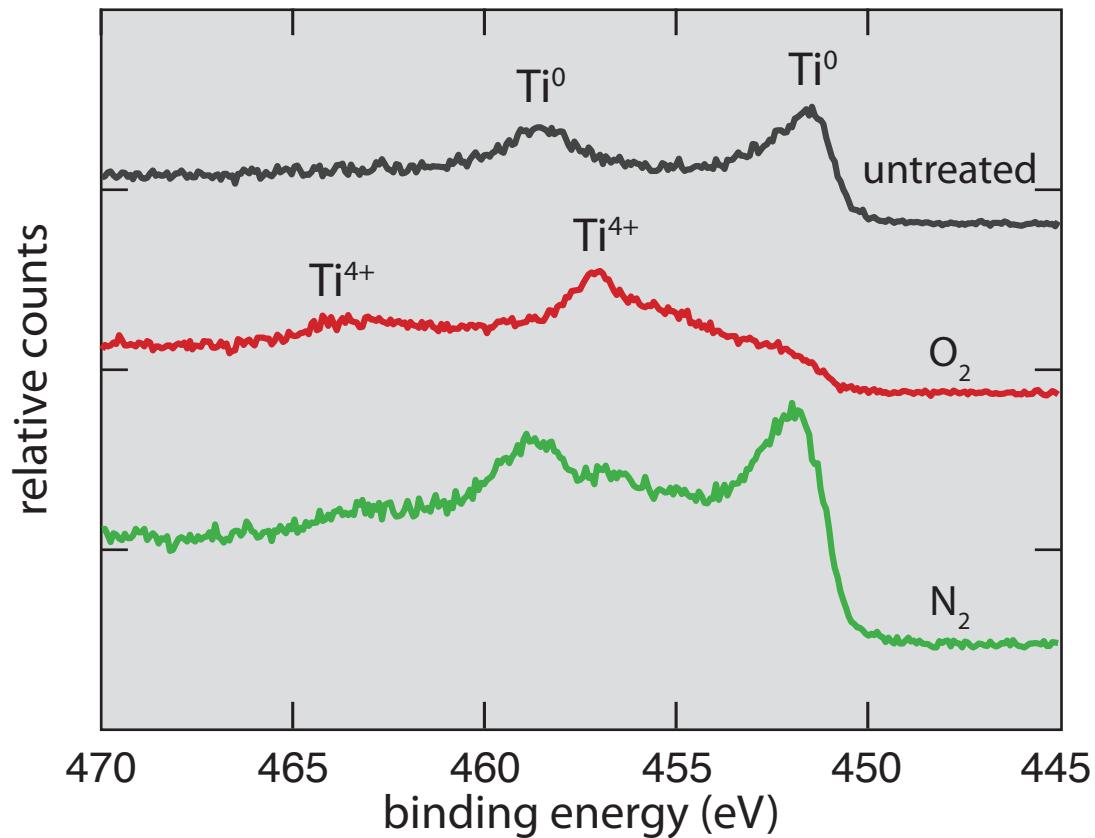


1 intermediate band

2 Si devices

3 $X:\text{TiO}_2$

... but nitrogen not chemically incorporated

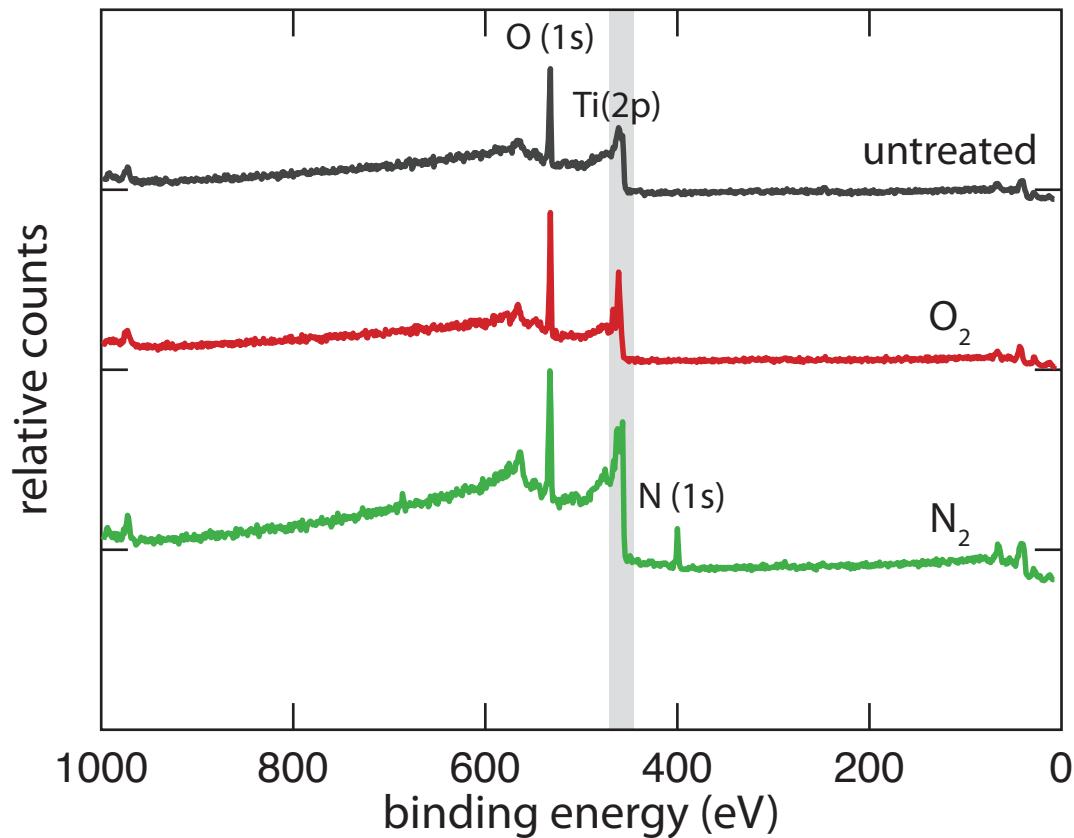


1 intermediate band

2 Si devices

3 X:TiO₂

... but nitrogen not chemically incorporated

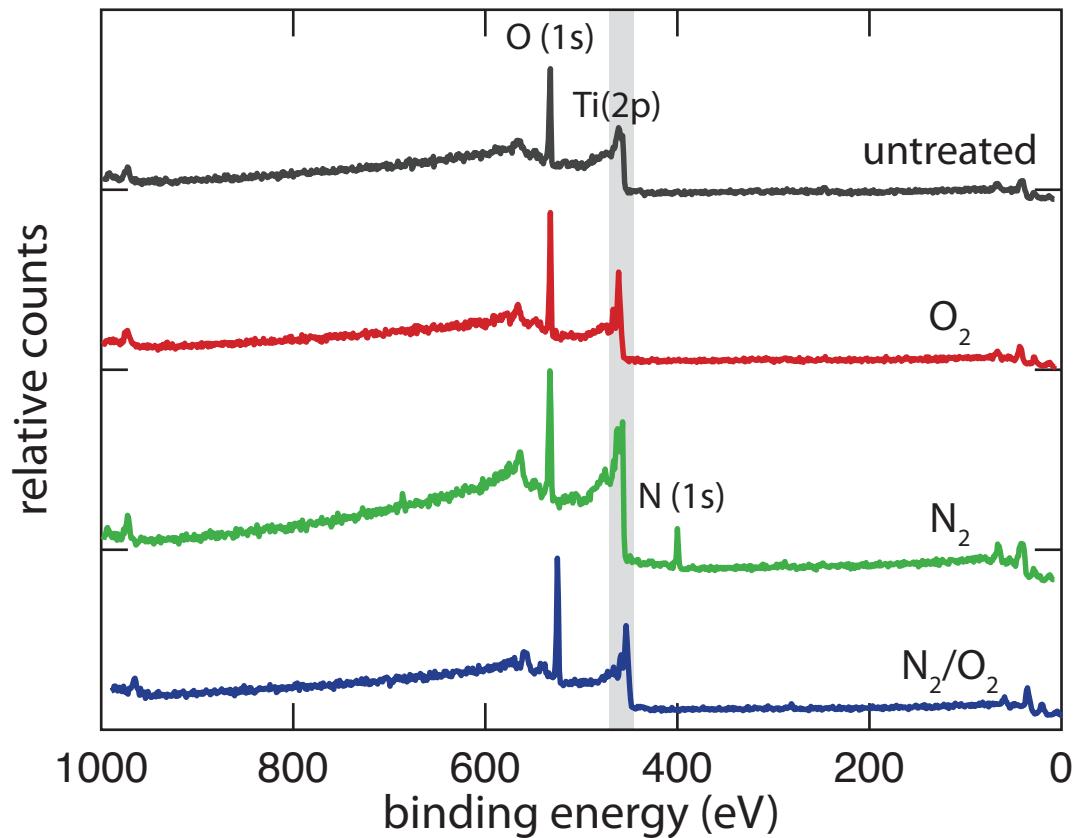


1 intermediate band

2 Si devices

3 X:TiO₂

with both nitrogen and oxygen...

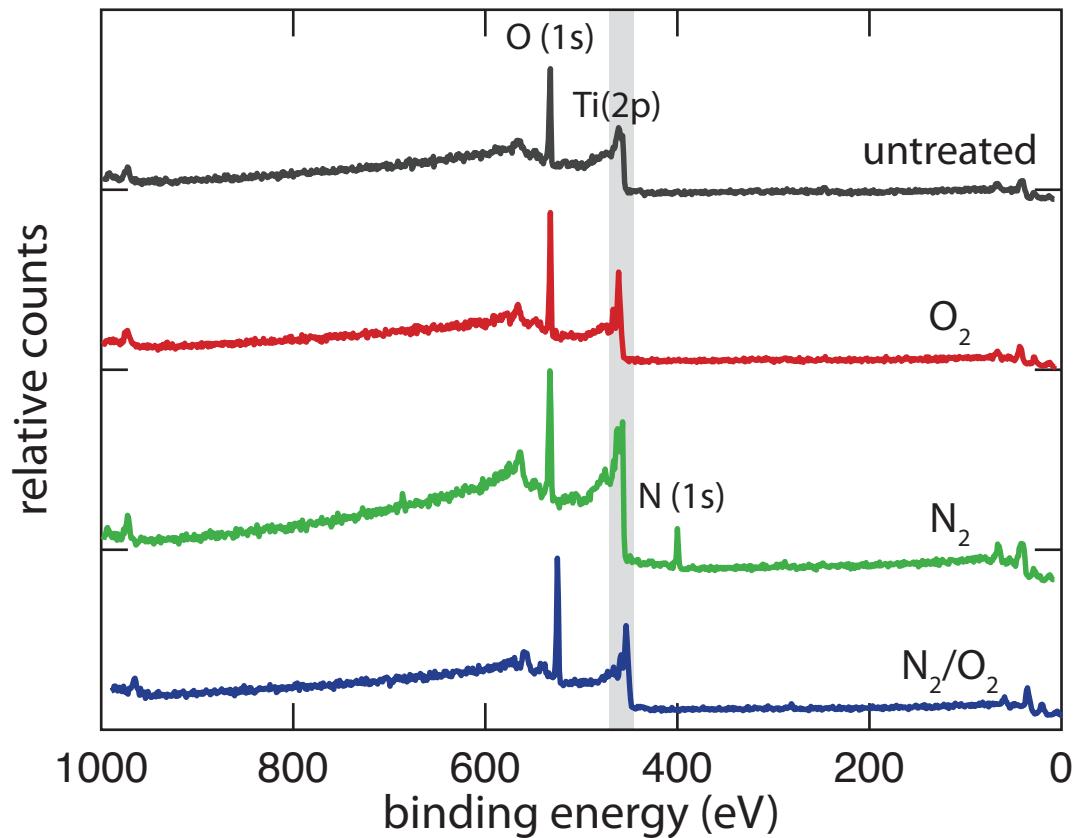


1 intermediate band

2 Si devices

3 X:TiO₂

... just 1% of oxygen prevents nitrogen incorporation...

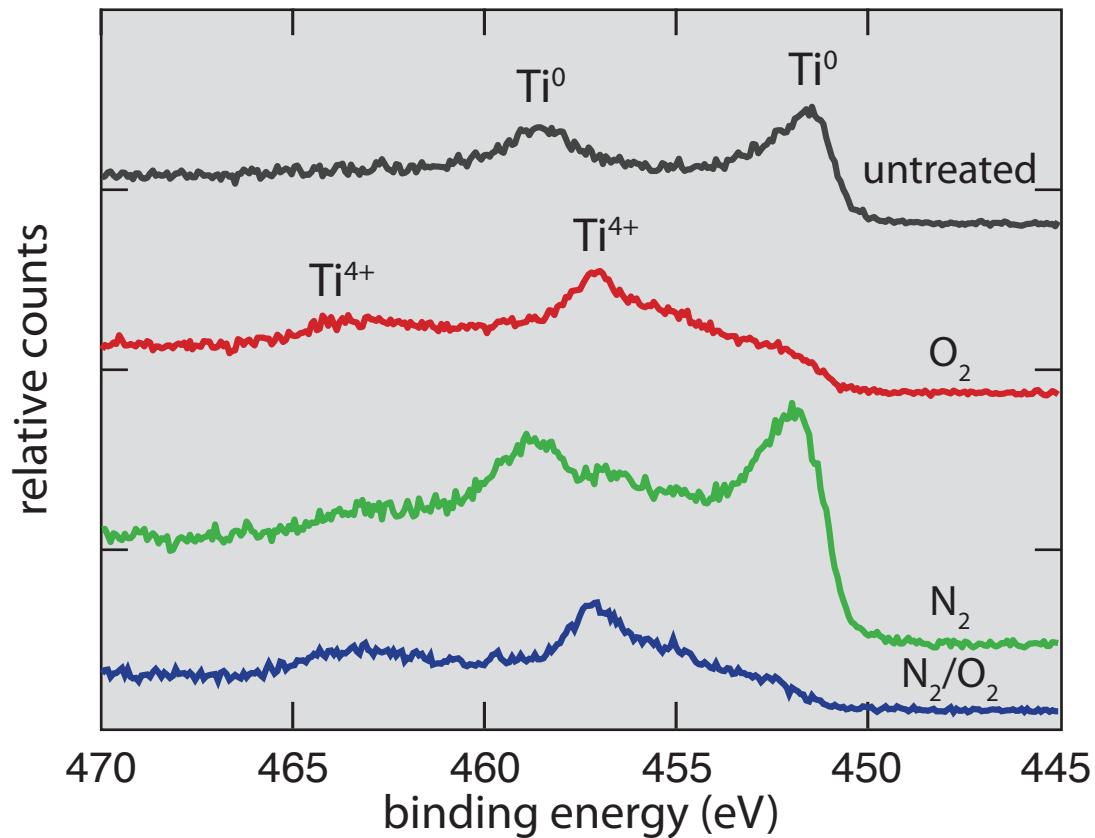


1 intermediate band

2 Si devices

3 X:TiO₂

... although oxygen is incorporated



1 intermediate band

2 Si devices

3 $\text{X}:\text{TiO}_2$

can get N_2 or O_2 incorporated, but not both

1 intermediate band

2 Si devices

3 X: TiO_2

can get N₂ or O₂ incorporated, but not both

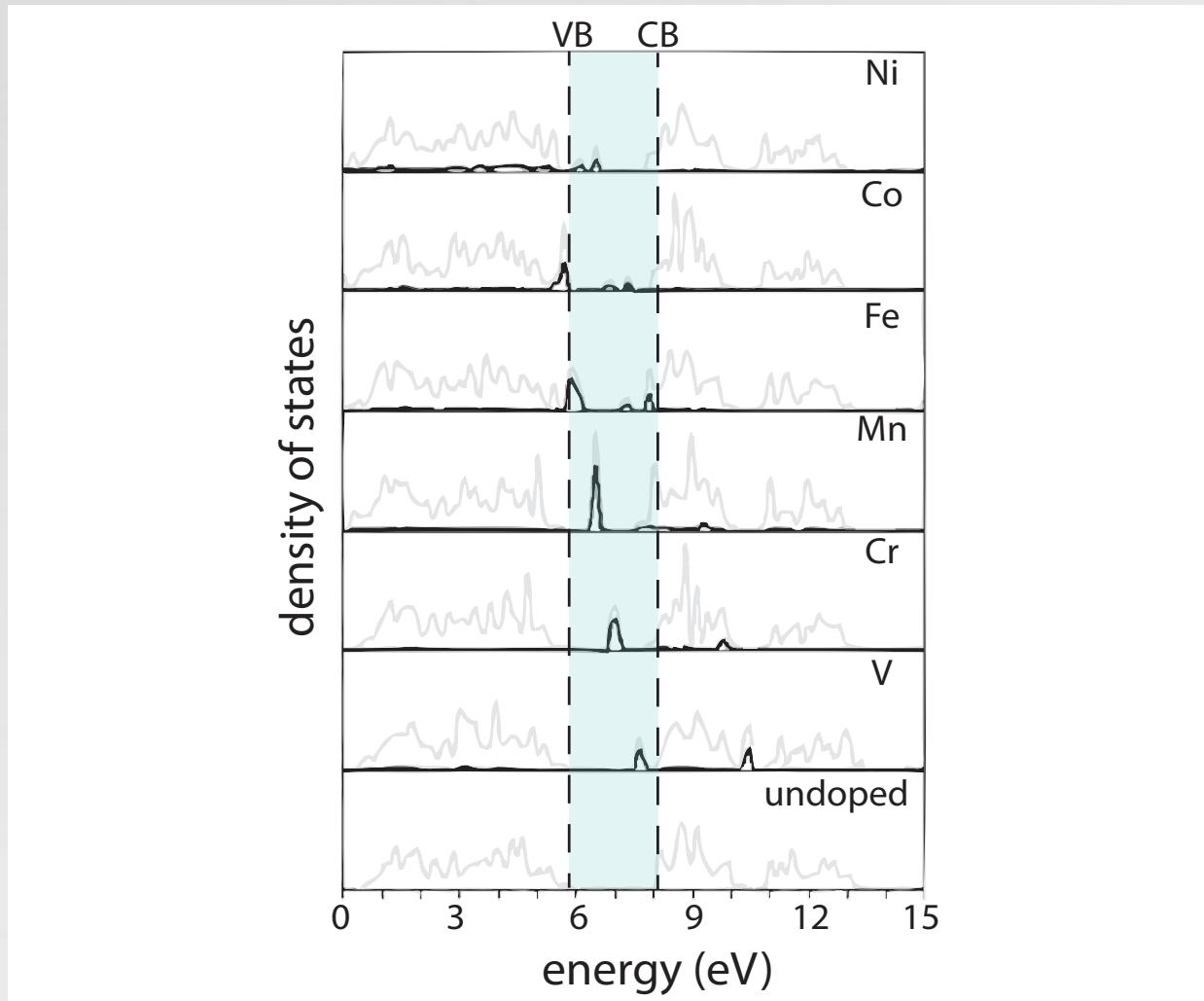
textured TiO₂/Ti: high biocompatibility

1 intermediate band

2 Si devices

3 X:TiO₂

TiO_2 density of states: other dopants



1 intermediate band

2 Si devices

3 X: TiO_2

how about incorporating chromium with oxygen?



Ti

1 intermediate band

2 Si devices

3 X:TiO₂

evaporate 10 – 70 nm chromium on titanium...

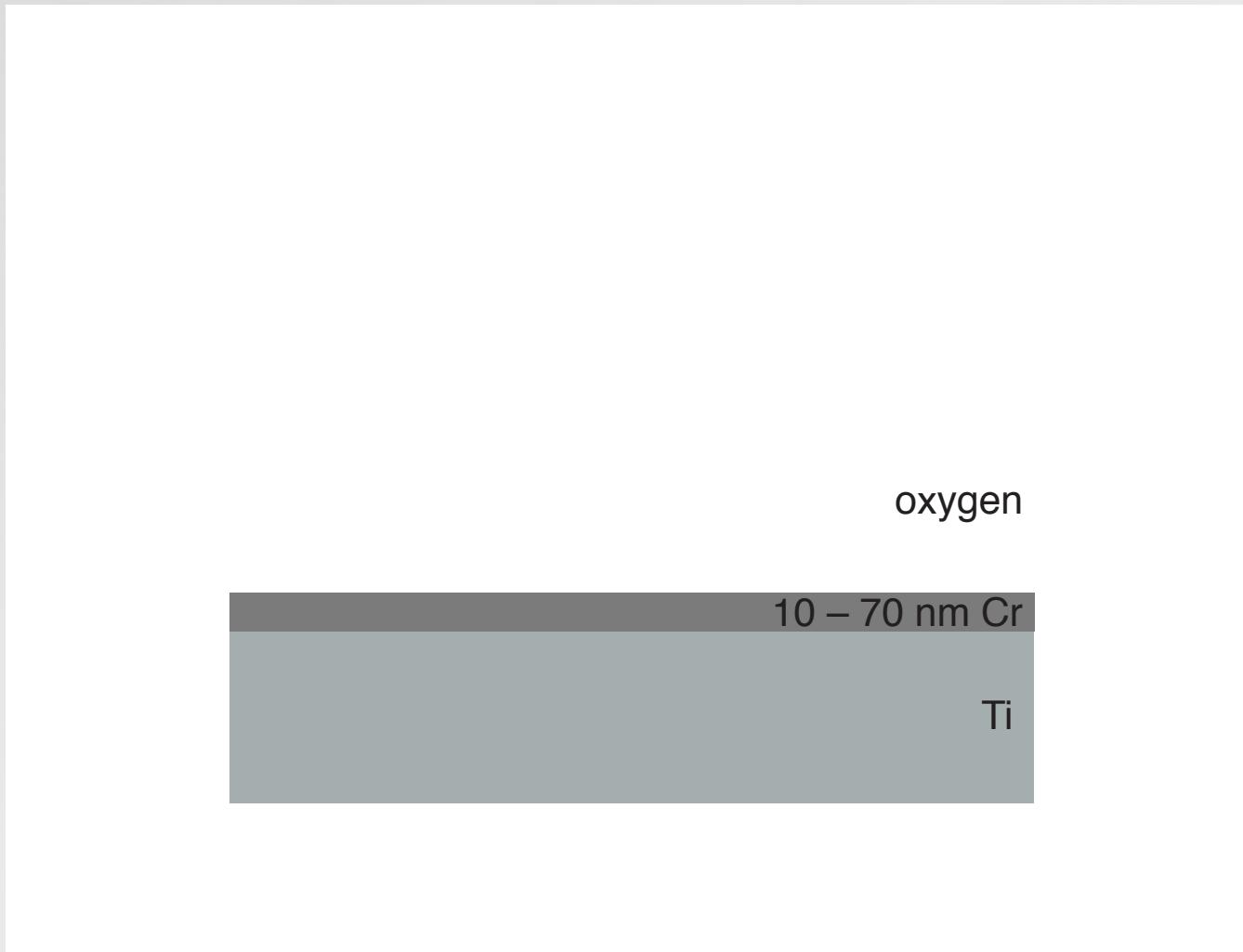


1 intermediate band

2 Si devices

3 X:TiO₂

...place in oxygen atmosphere...

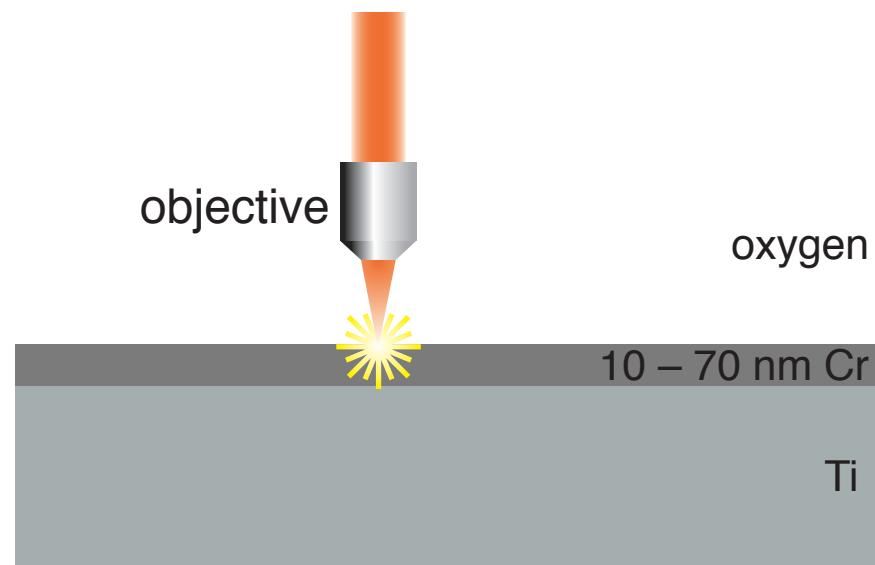


1 intermediate band

2 Si devices

3 X:TiO₂

...irradiate with laser...



1 intermediate band

2 Si devices

3 X:TiO₂

...and raster scan to structure

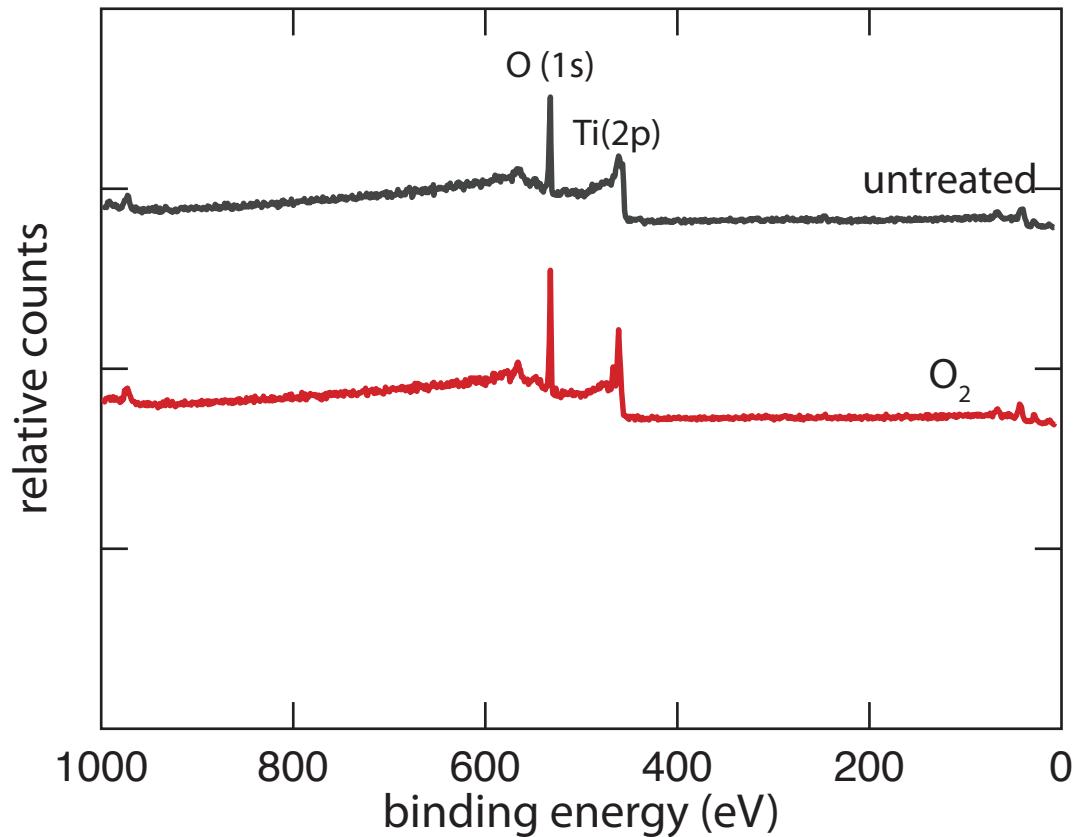


1 intermediate band

2 Si devices

3 X:TiO₂

X-ray photoelectron spectroscopy

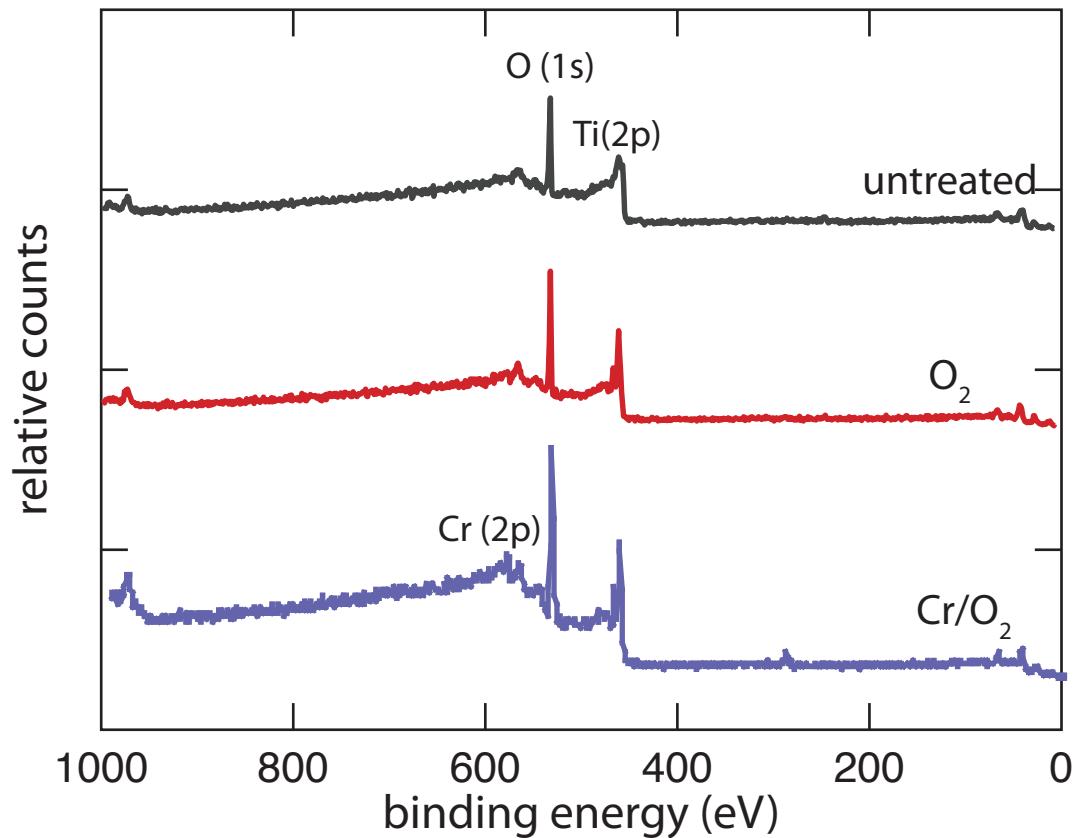


1 intermediate band

2 Si devices

3 X:TiO₂

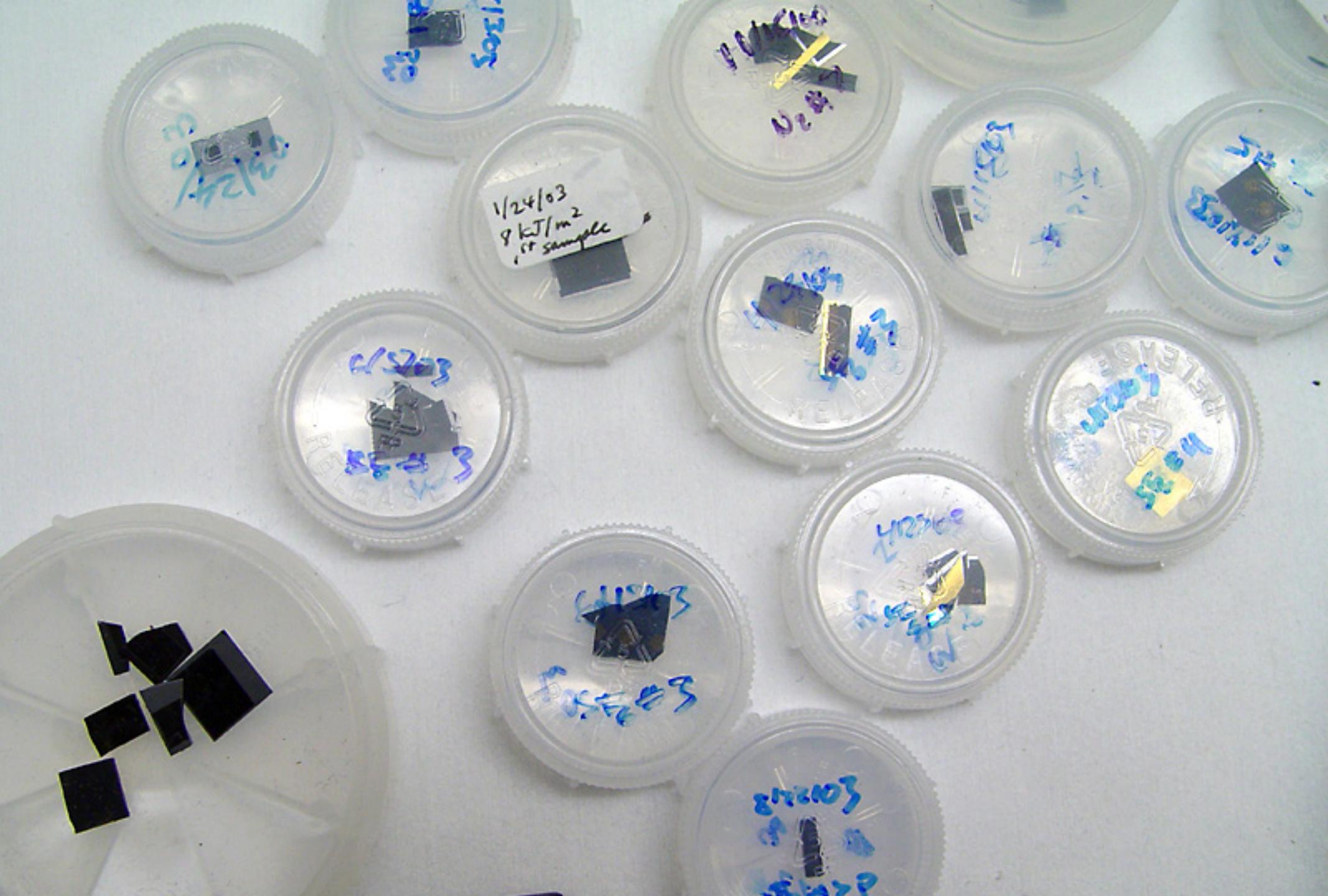
both chromium and oxygen incorporated!



1 intermediate band

2 Si devices

3 X:TiO₂



1 intermediate band

2 Si devices

3 X:TiO₂

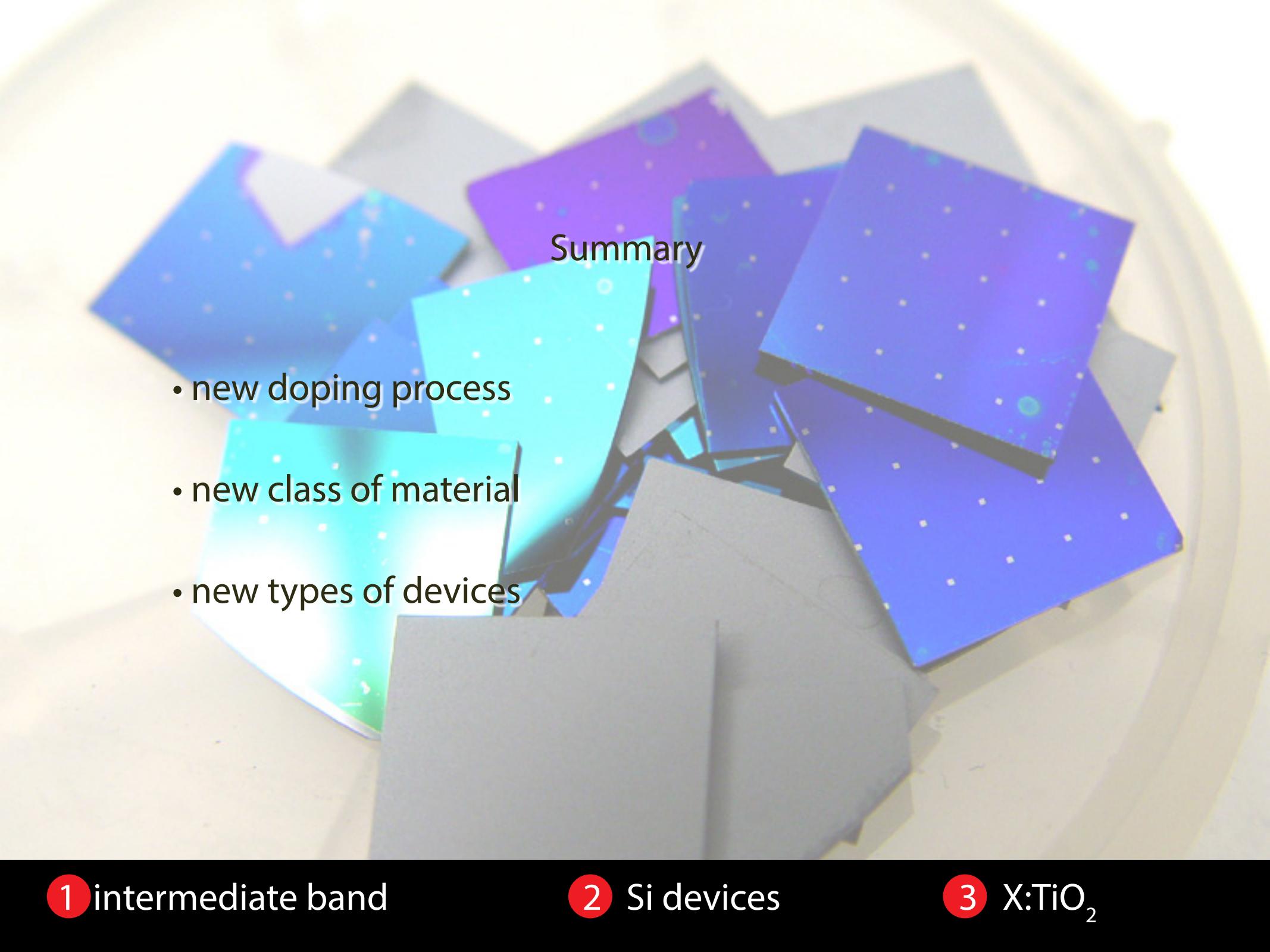
Can produce:

- microstructured TiO_2 (high biocompatibility)
- can dope TiO_2 with Cr, but not N

1 intermediate band

2 Si devices

3 X: TiO_2



Summary

- new doping process
- new class of material
- new types of devices

1 intermediate band

2 Si devices

3 X:TiO₂



A group of approximately 20 people of diverse ages and ethnicities are sitting on a grassy hillside. They are dressed in casual attire, including t-shirts, polo shirts, and a vest. Some individuals are holding small flags or banners. In the background, a city skyline with several skyscrapers is visible under a clear sky.

Funding:

Army Research Office

DARPA

Department of Energy

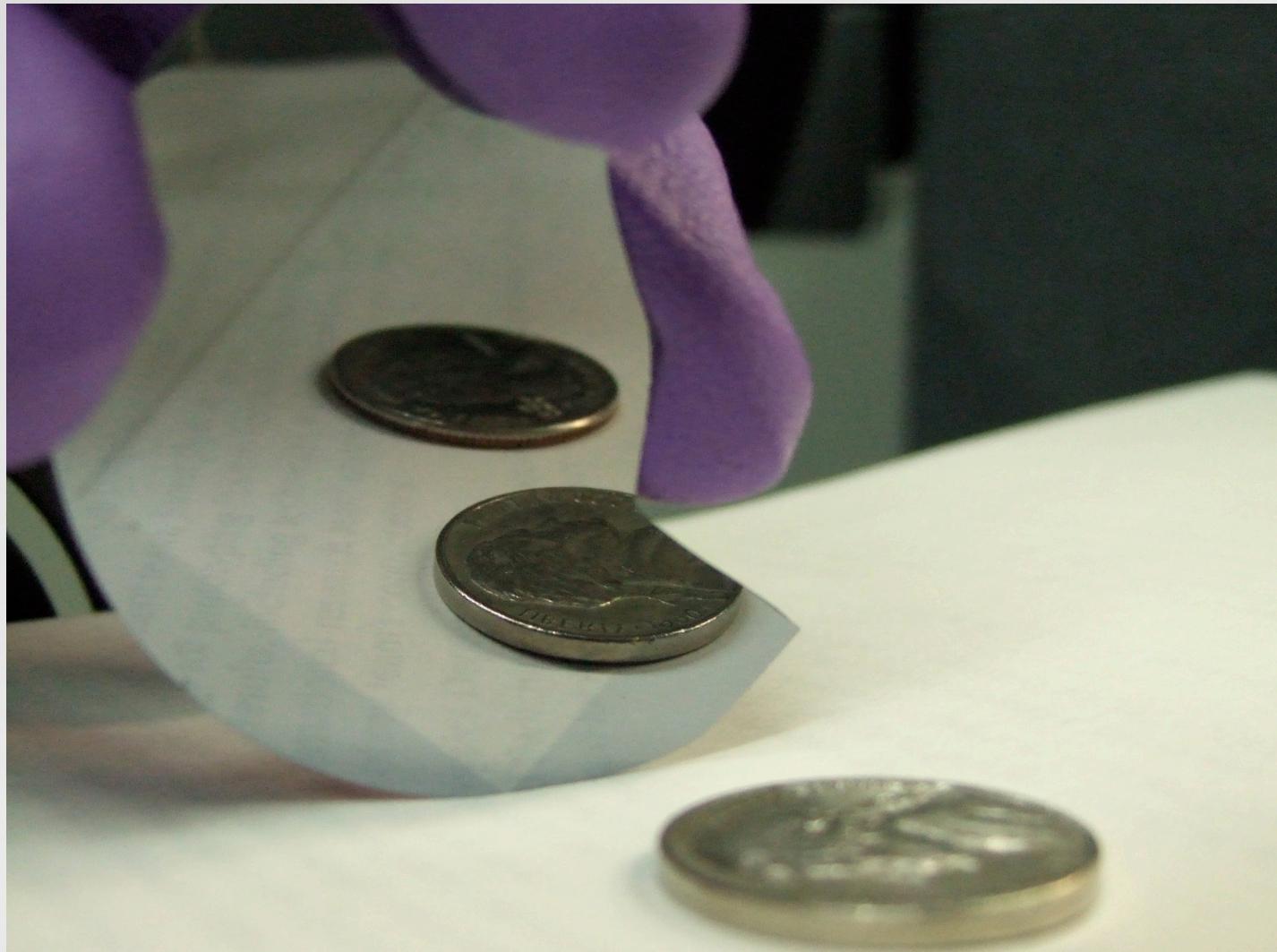
NDSEG

National Science Foundation

for more information and a copy of this presentation:

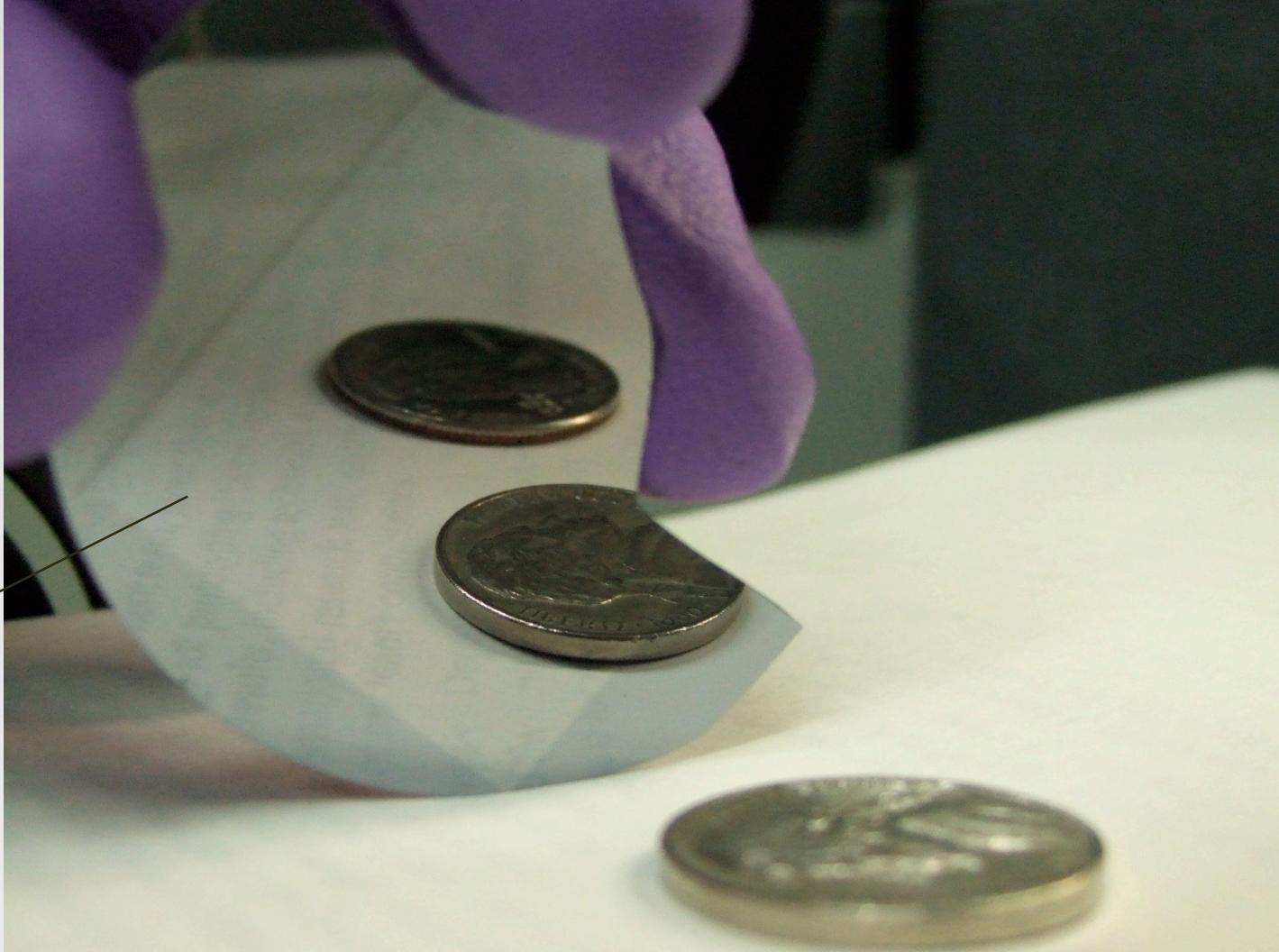
<http://mazur.harvard.edu>

decouple ablation from melting



1 intermediate band

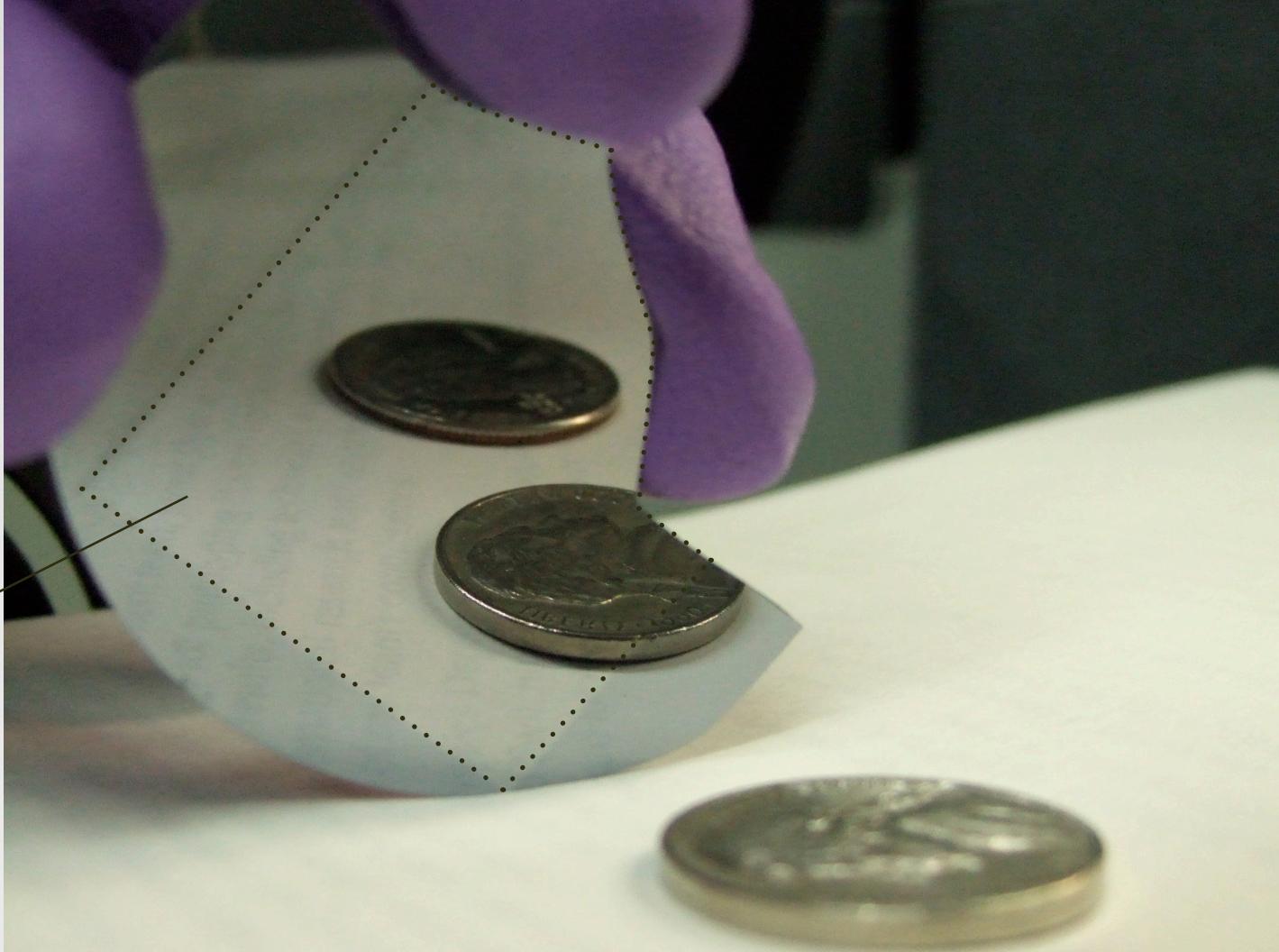
decouple ablation from melting



doped

1 intermediate band

decouple ablation from melting



doped

1 intermediate band

decouple ablation from melting



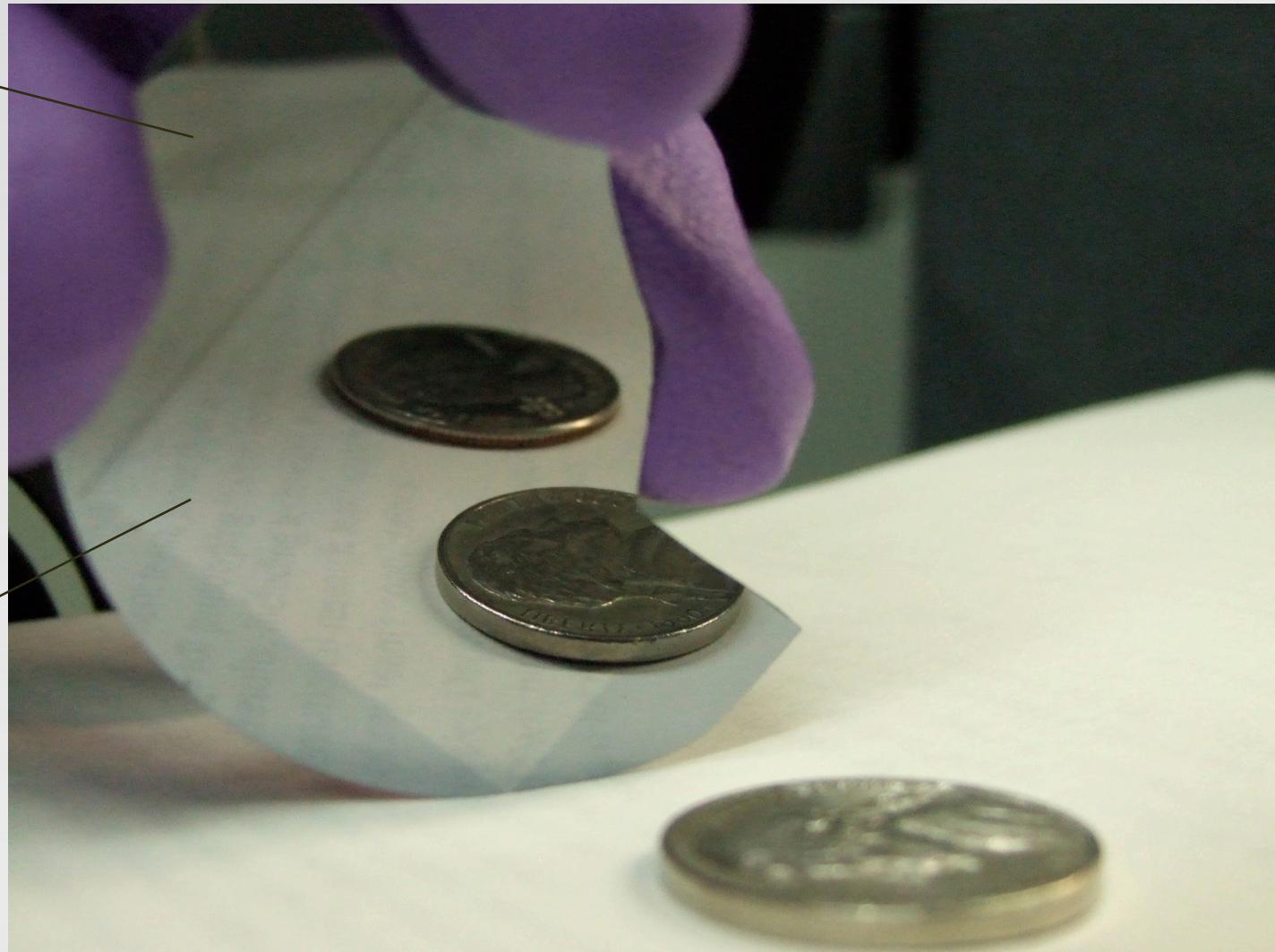
doped

1 intermediate band

decouple ablation from melting

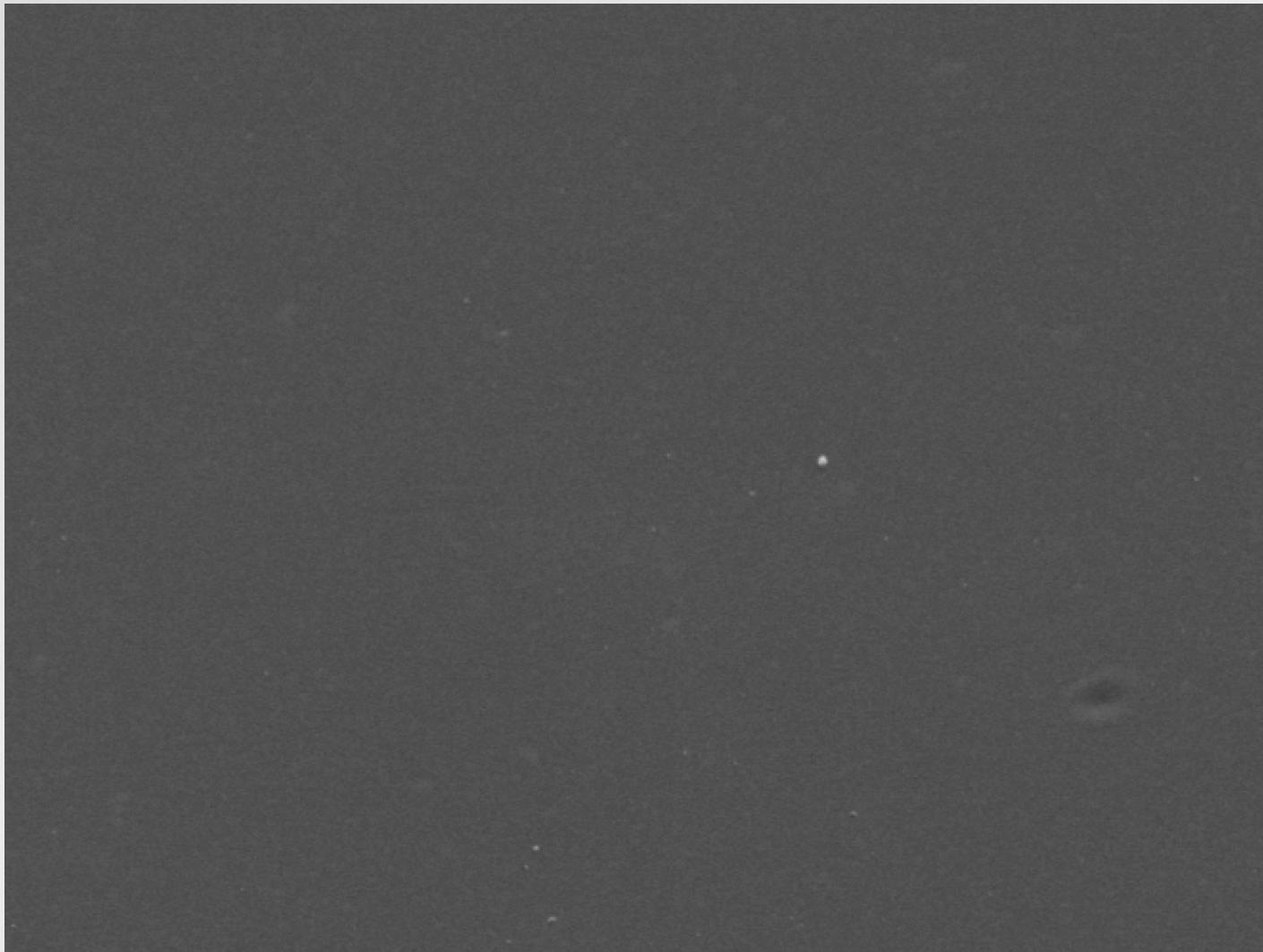
undoped

doped

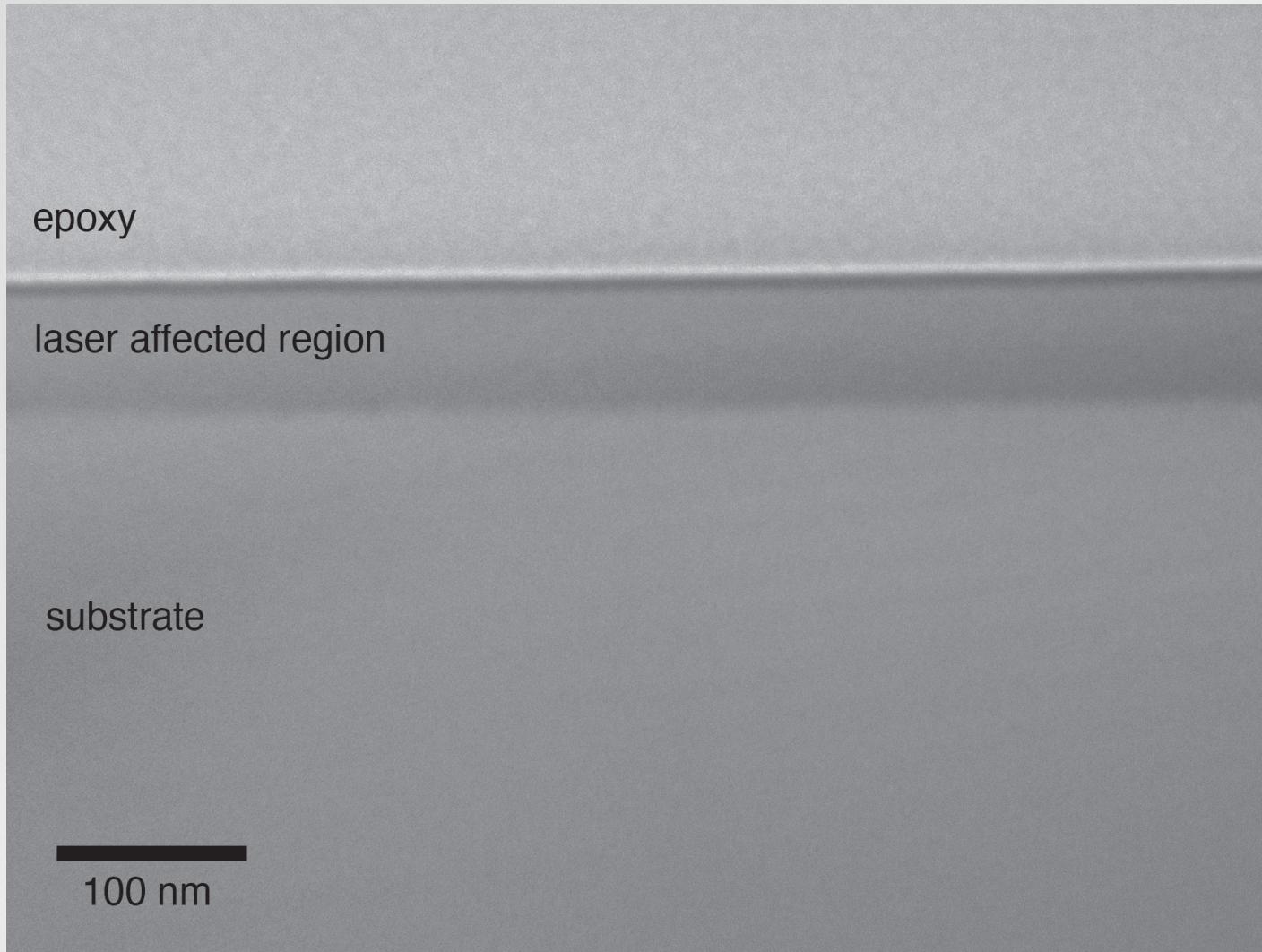


1 intermediate band

decouple ablation from melting

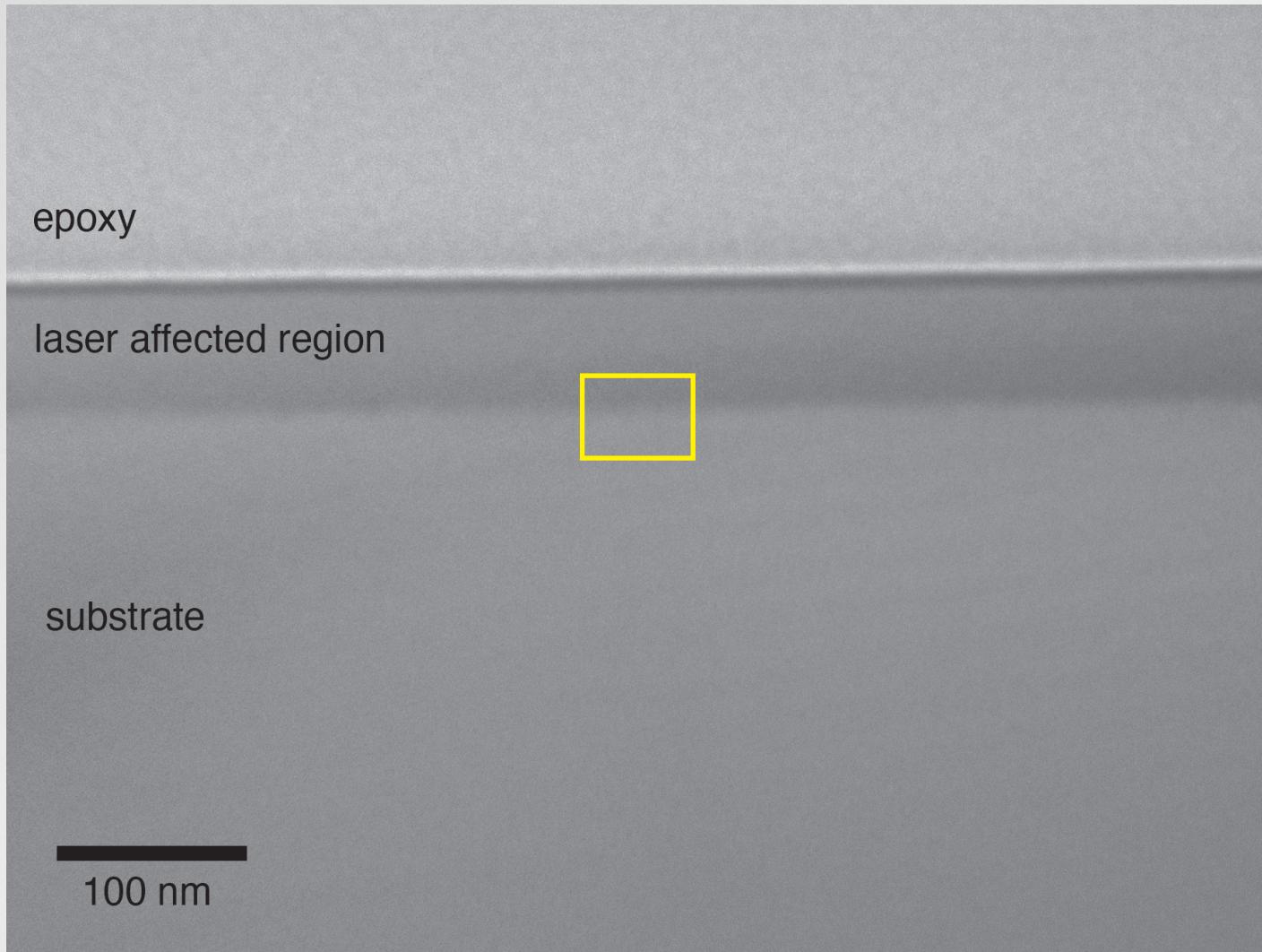


decouple ablation from melting



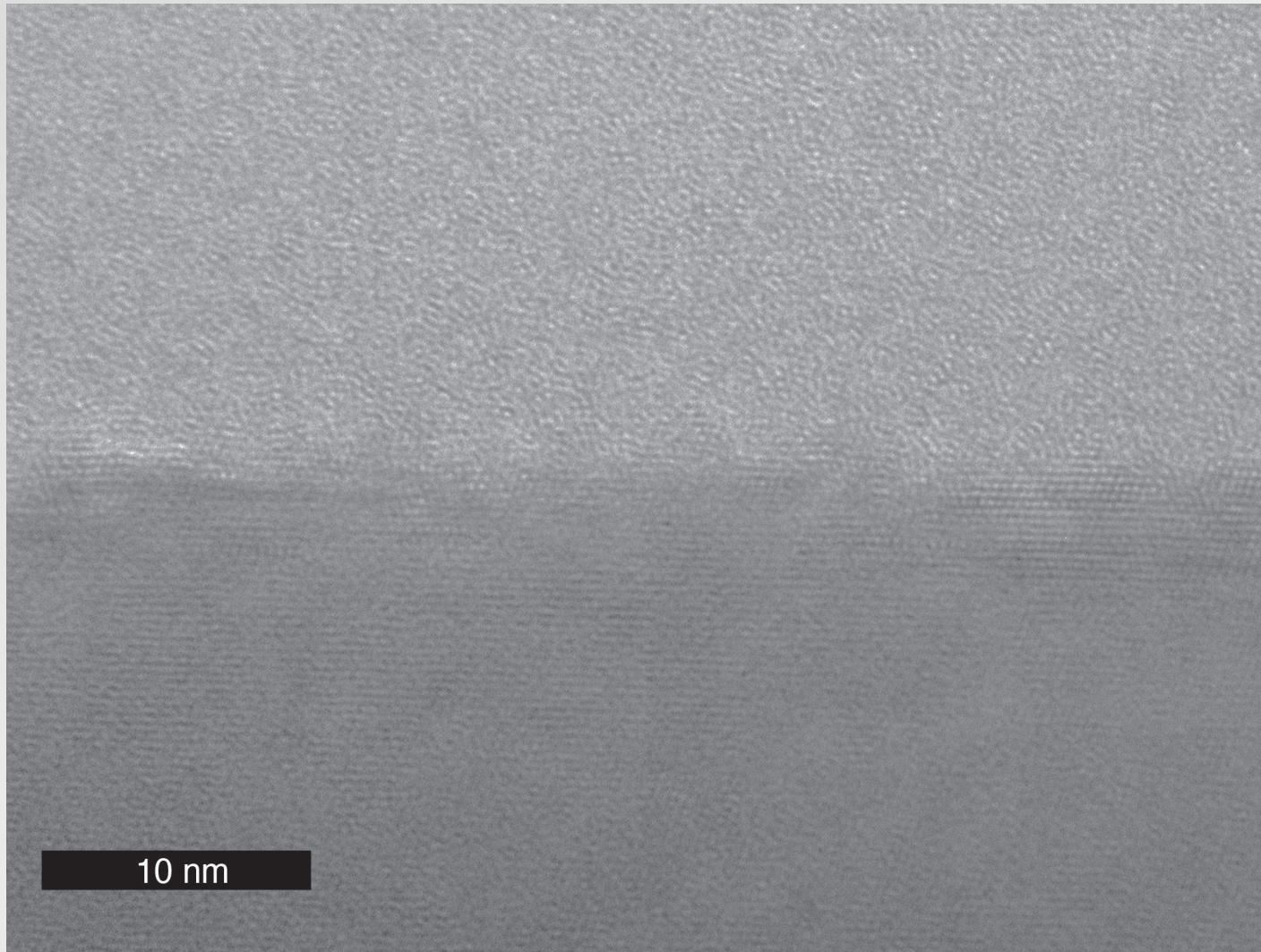
1 intermediate band

decouple ablation from melting



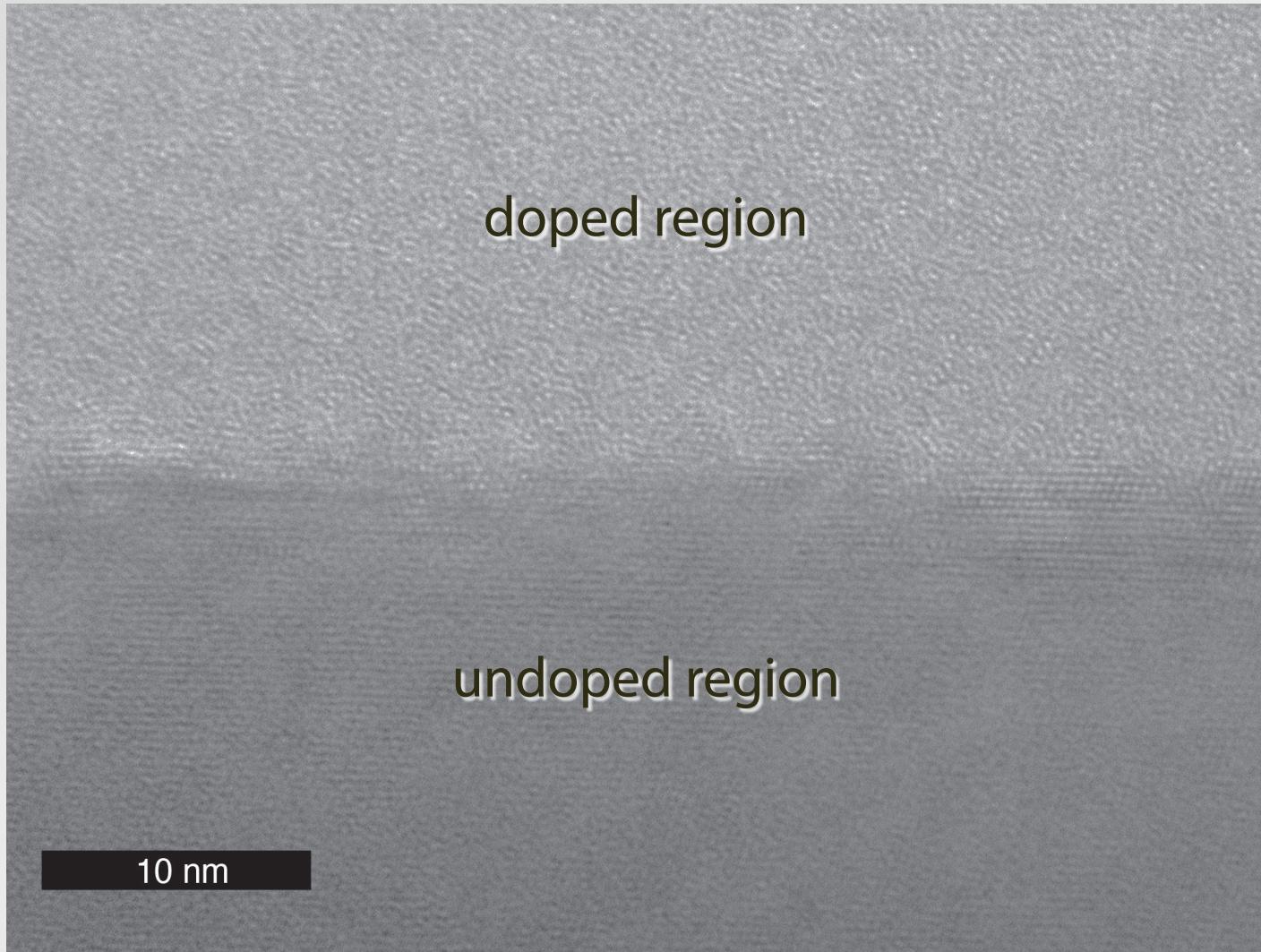
1 intermediate band

decouple ablation from melting

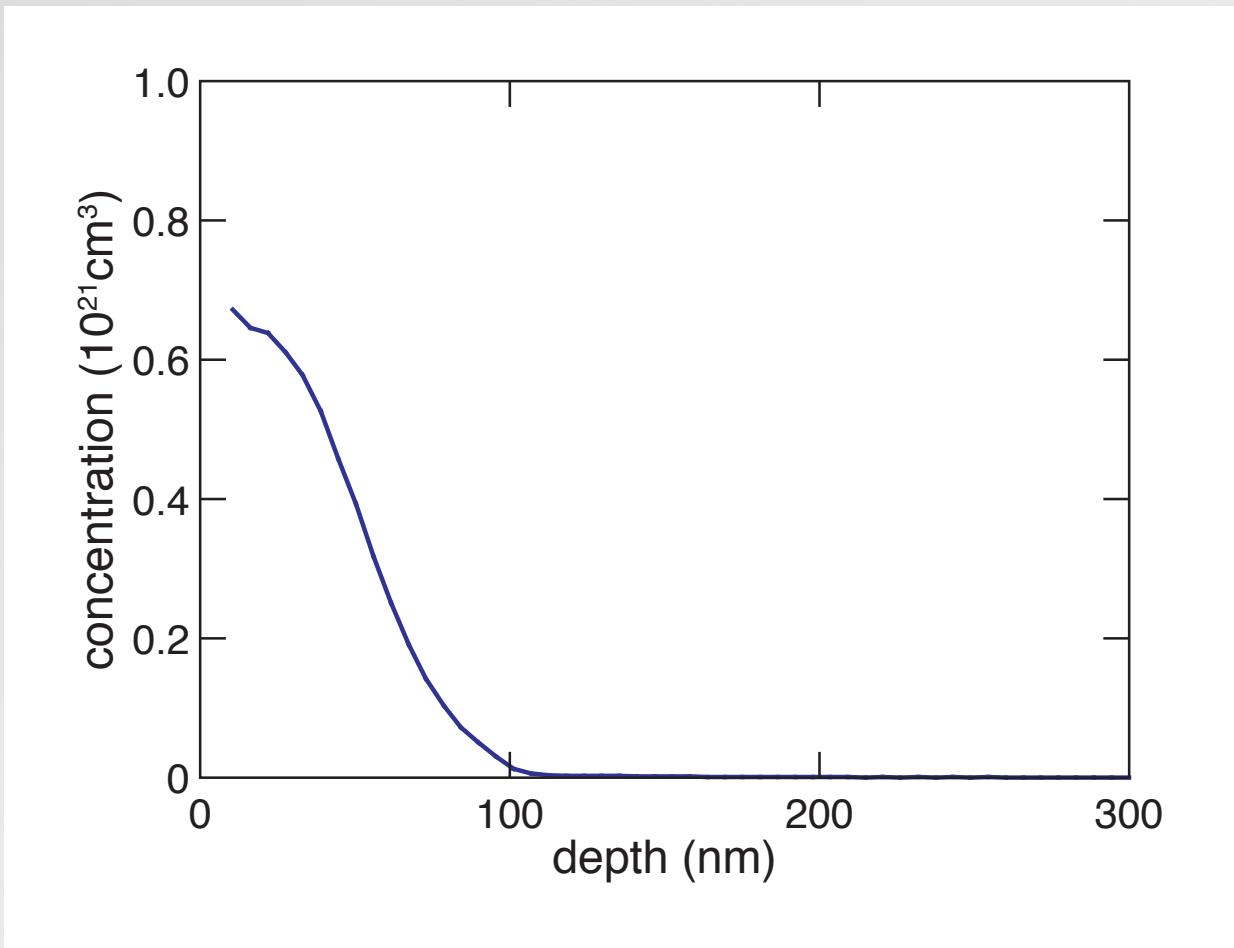


1 intermediate band

decouple ablation from melting

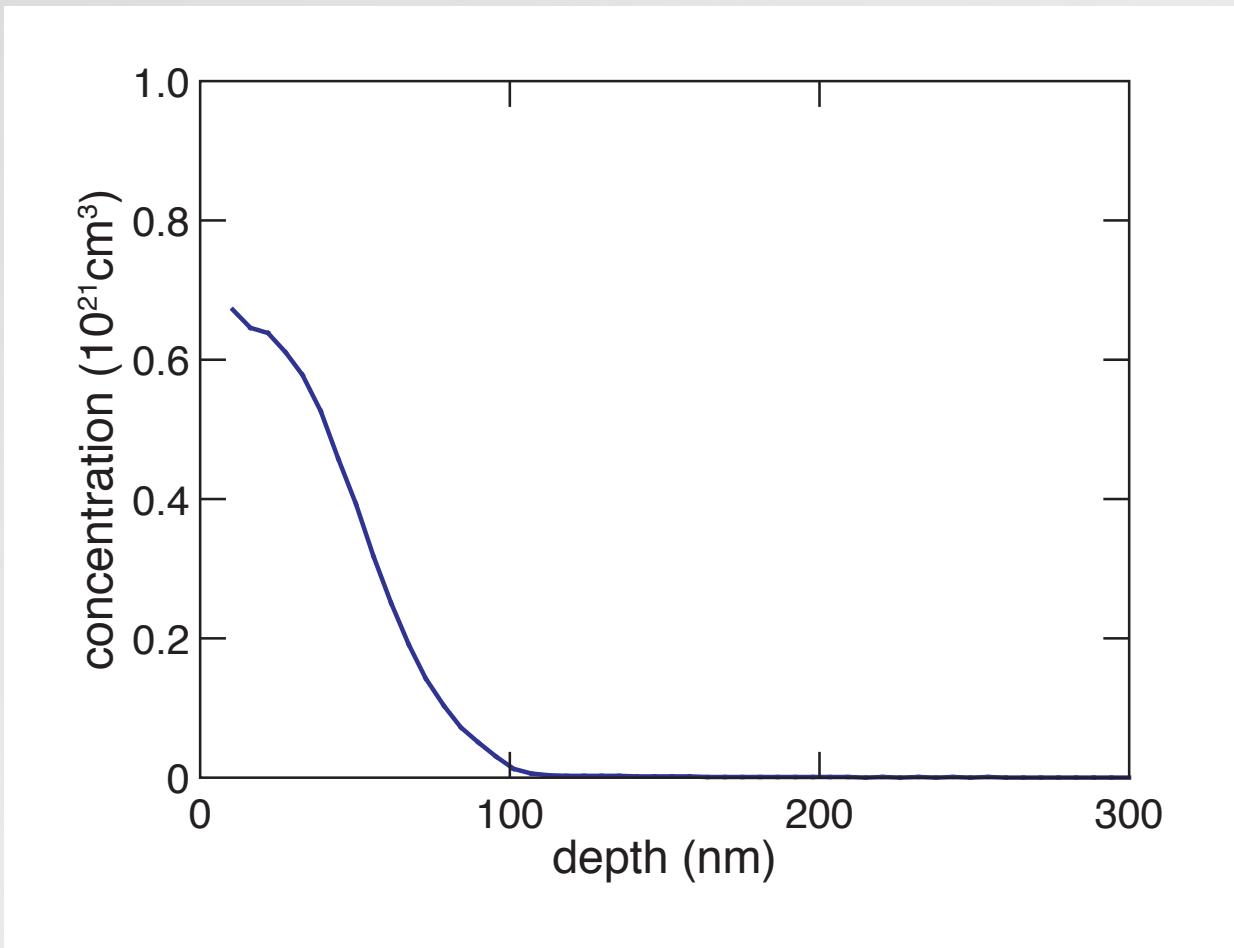


secondary ion mass spectrometry



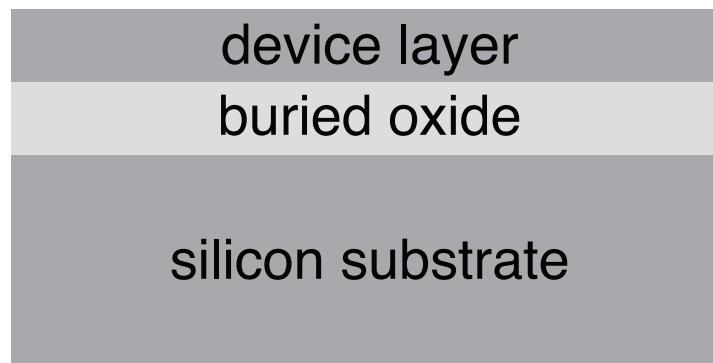
1 intermediate band

secondary ion mass spectrometry

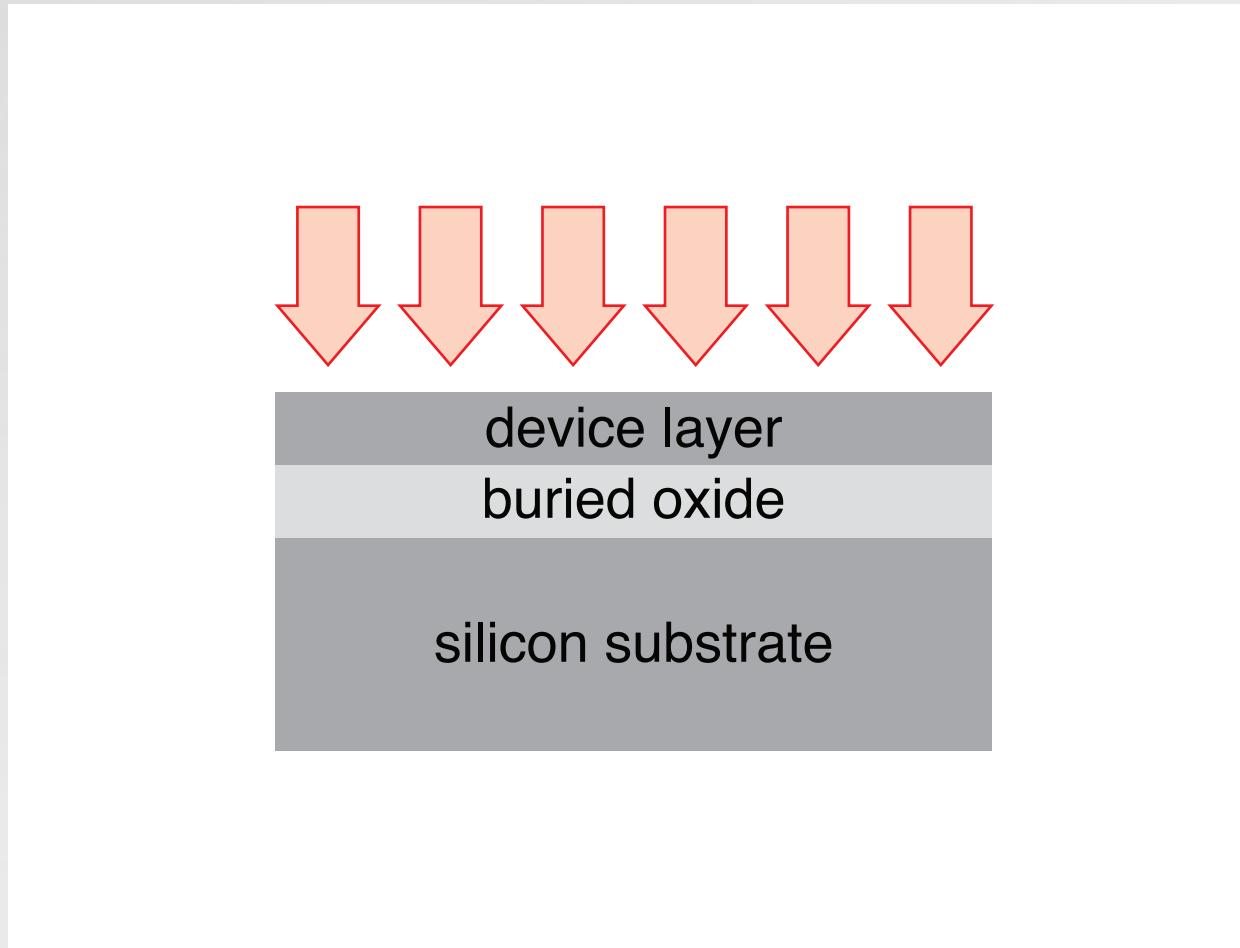


1 intermediate band

isolate surface layer for Hall measurements

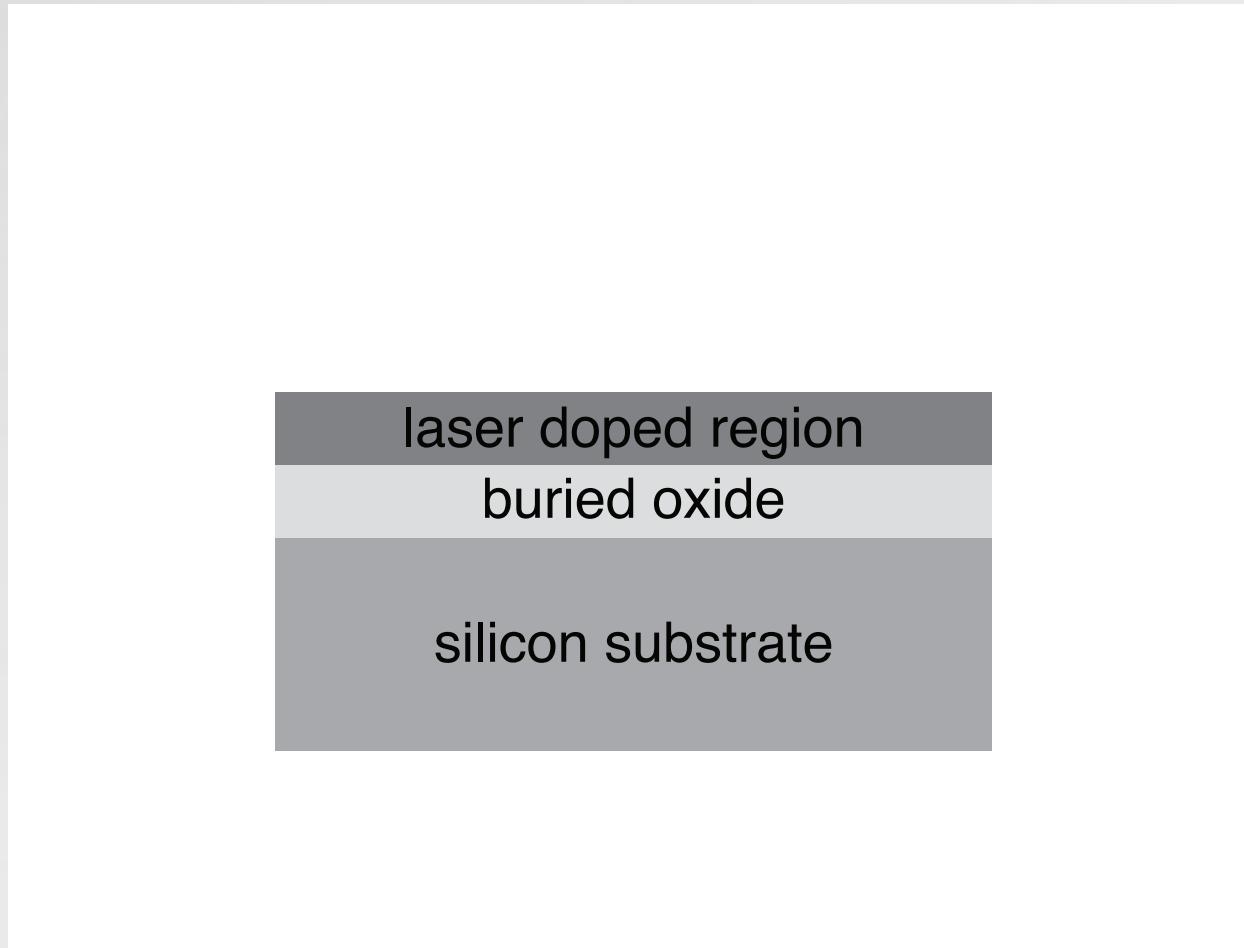


isolate surface layer for Hall measurements

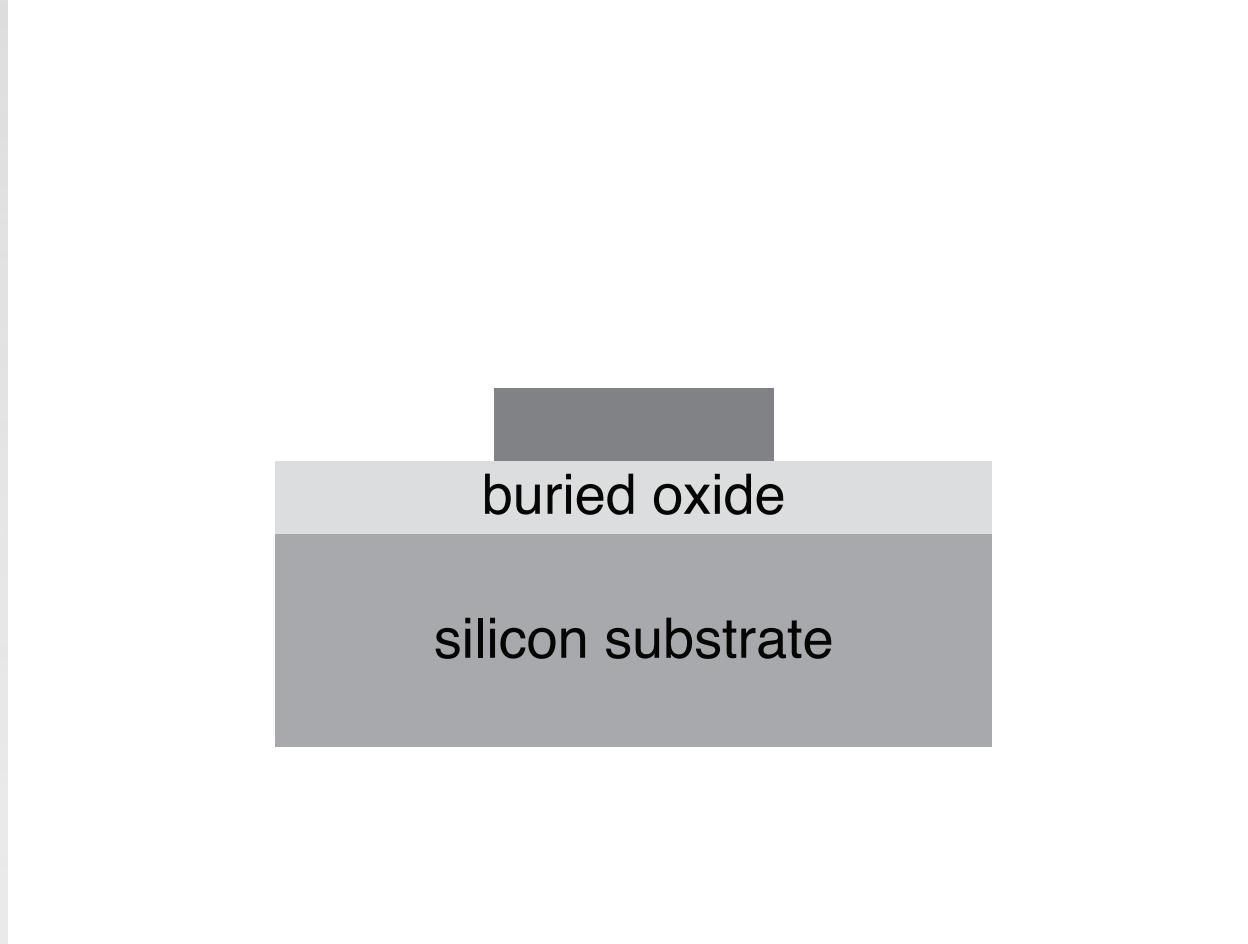


1 intermediate band

isolate surface layer for Hall measurements

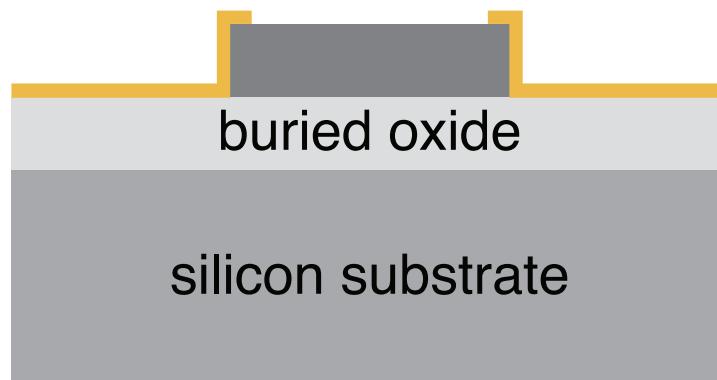


isolate surface layer for Hall measurements

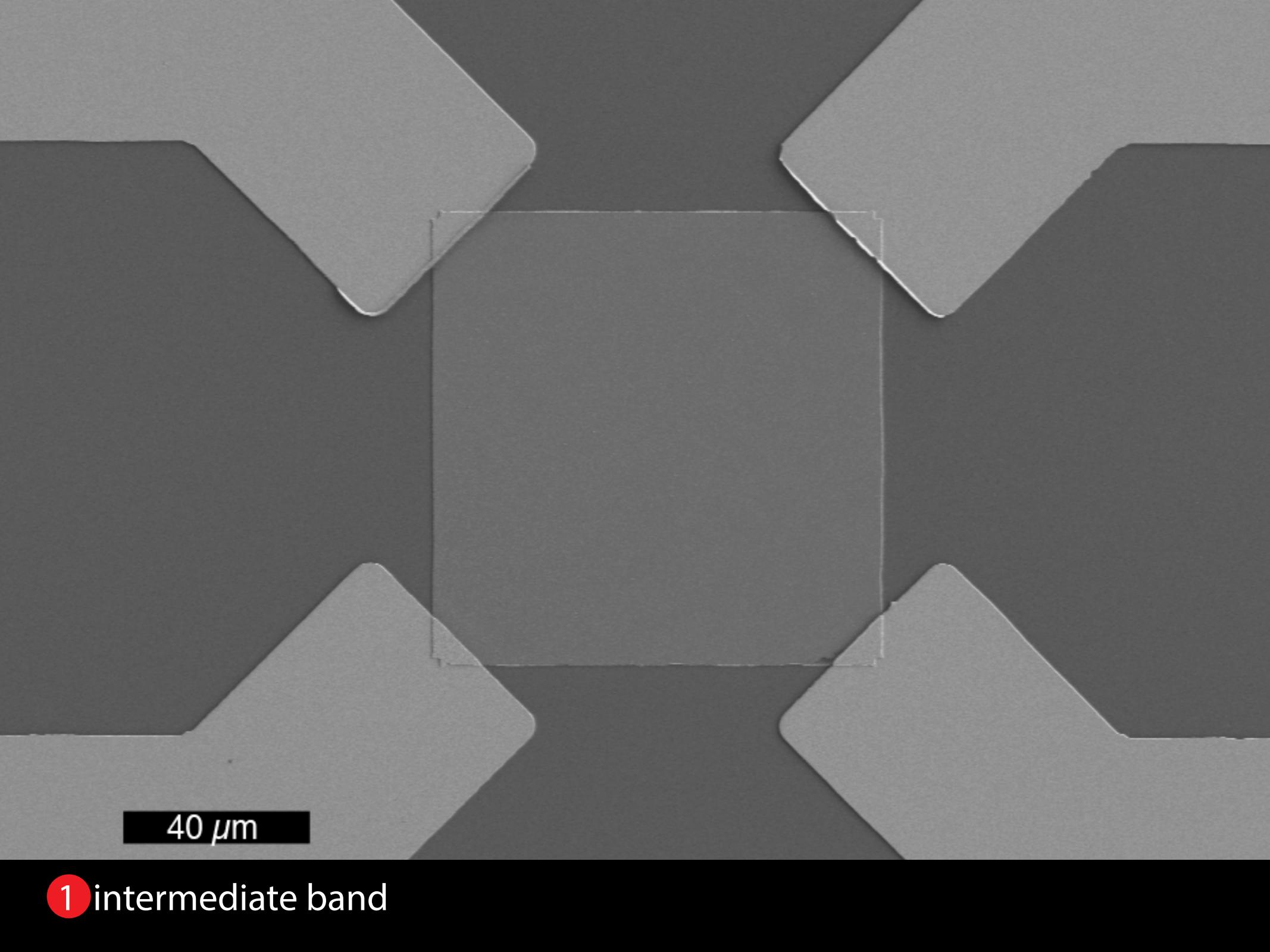


1 intermediate band

isolate surface layer for Hall measurements



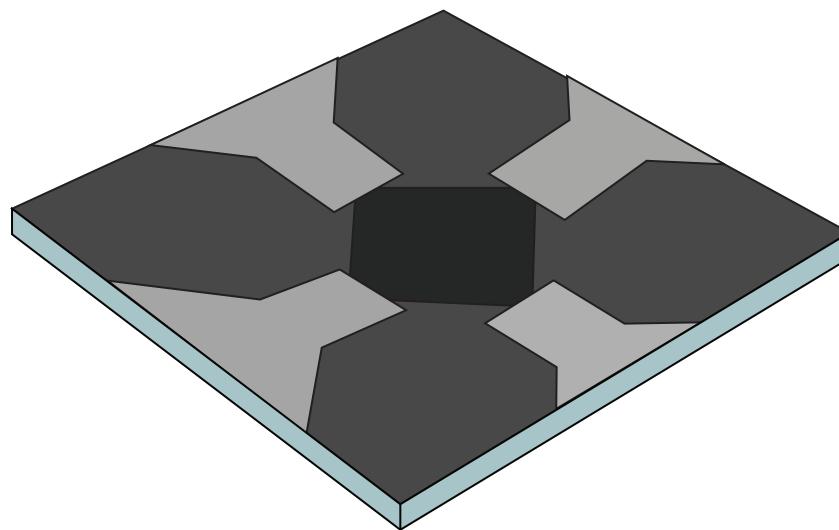
1 intermediate band



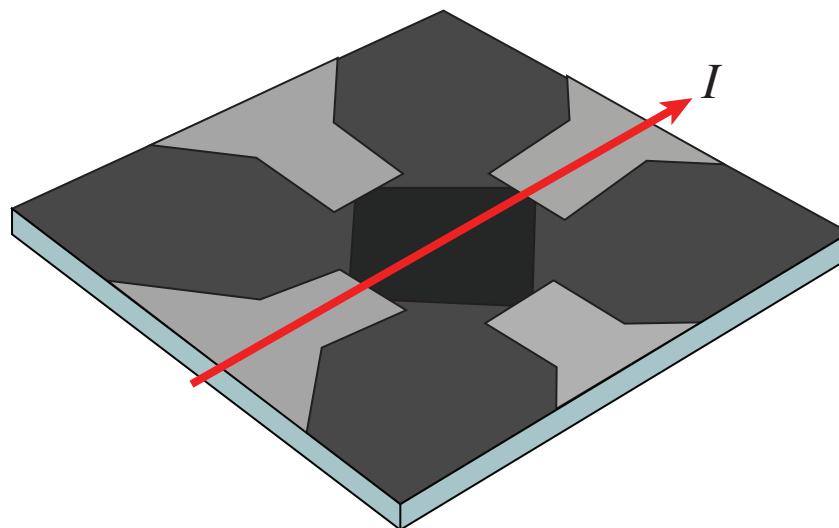
40 μm

1 intermediate band

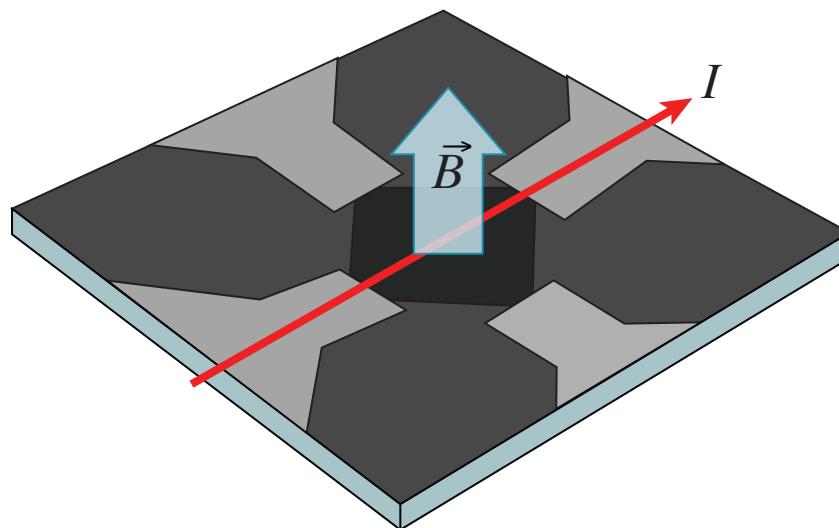
Hall measurements



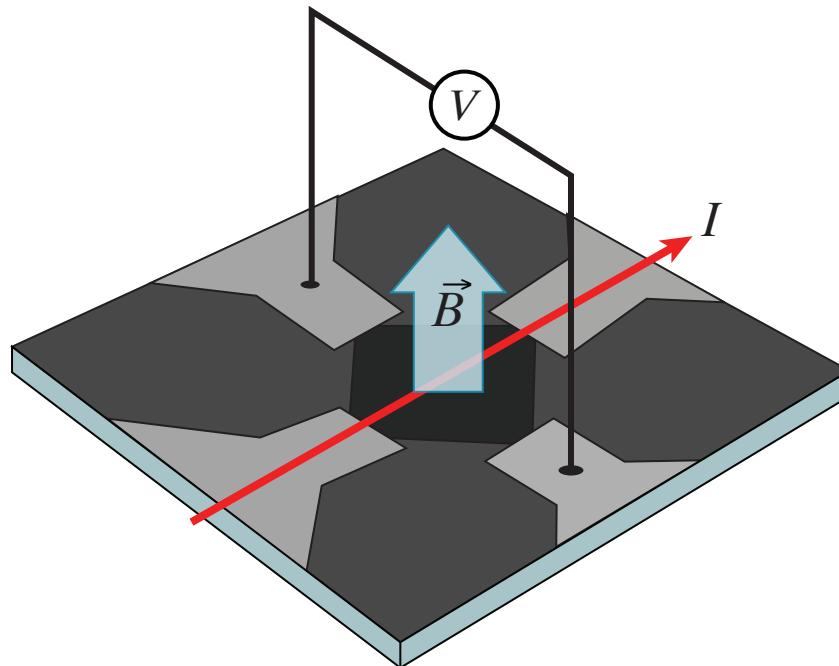
Hall measurements



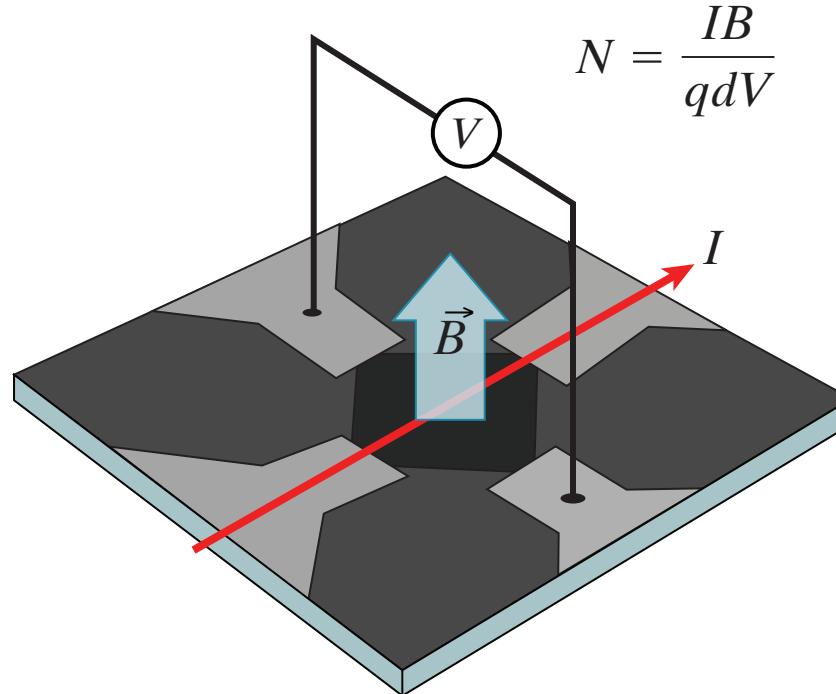
Hall measurements



Hall measurements



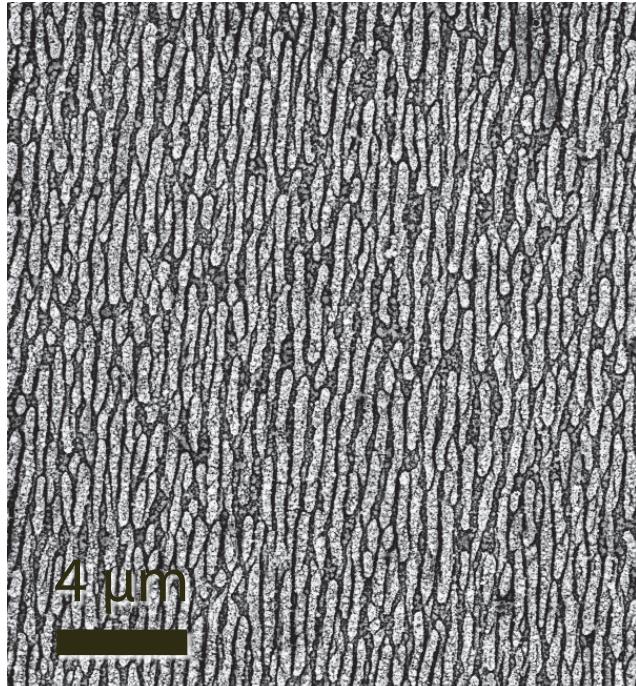
Hall measurements



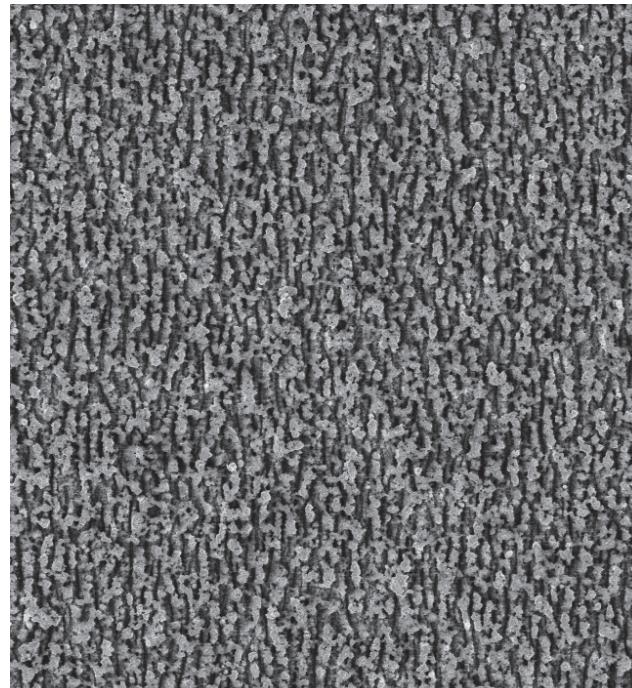
$$N = \frac{IB}{qdV}$$

titanium/chromium in oxygen

titanium only



titanium/chromium



1 intermediate band

2 Si devices

3 X:TiO₂

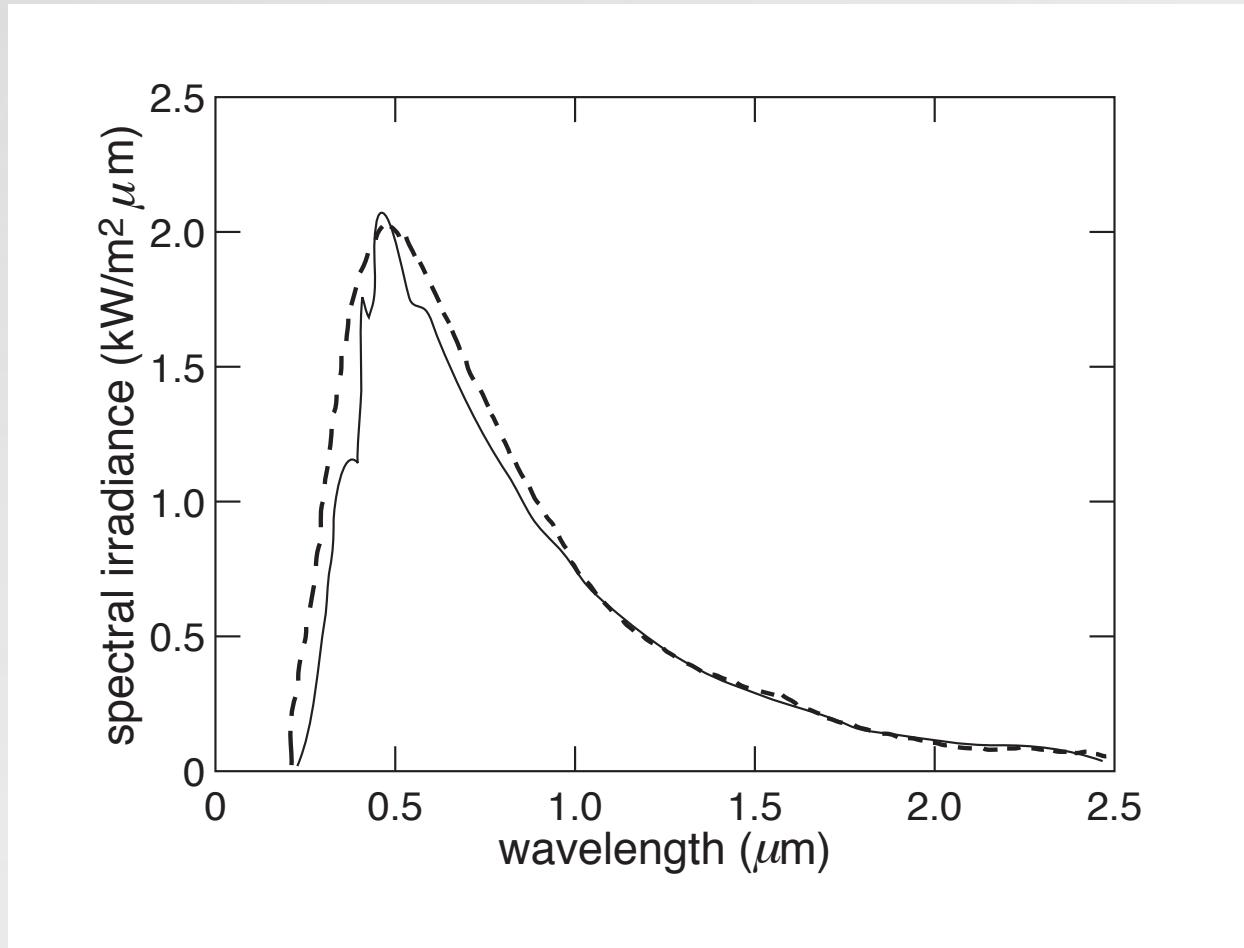
two processes: melting and ablation

different thresholds:

melting: 1.5 kJ/m^2

ablation: 3.1 kJ/m^2

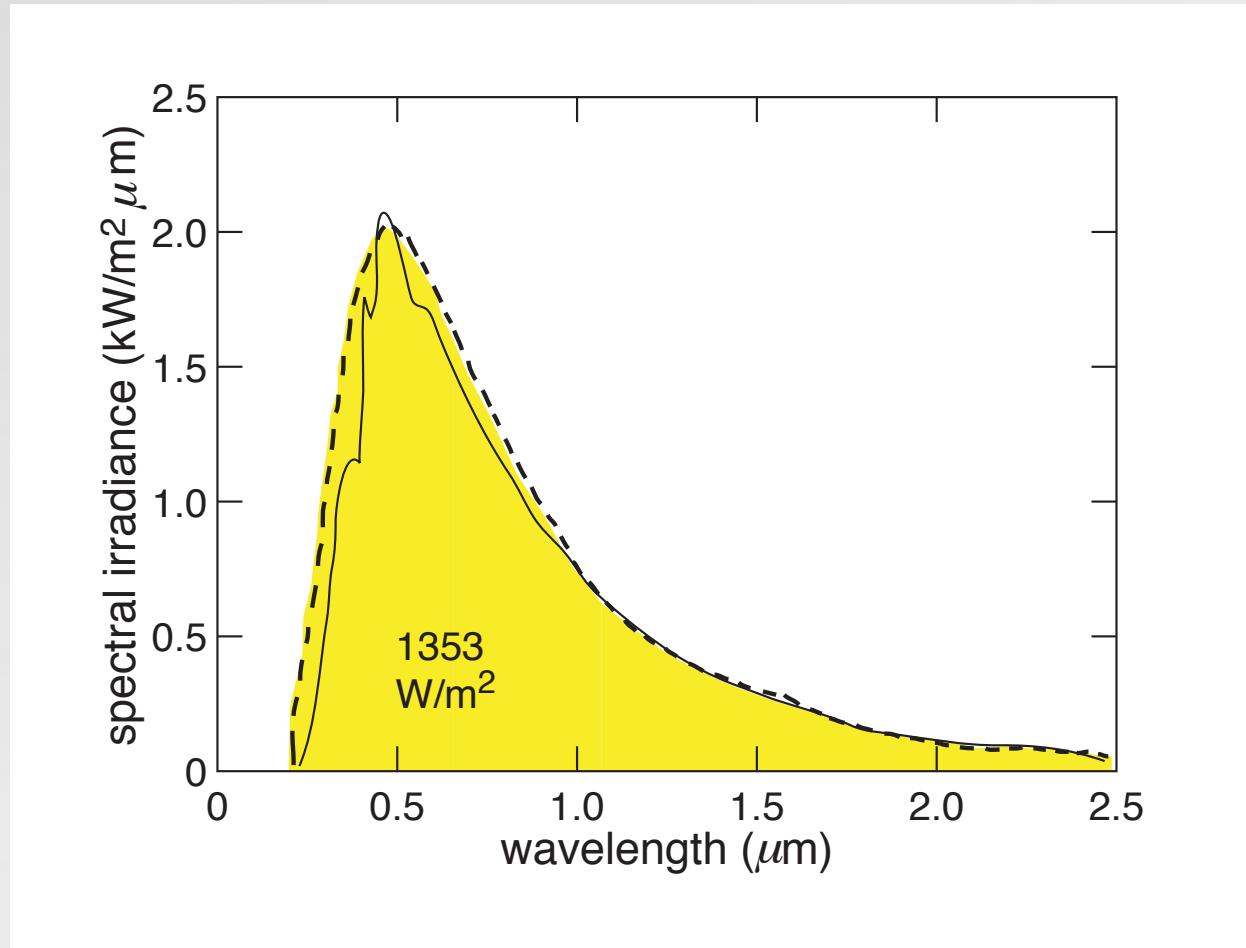
solar spectrum



1 intermediate band

2 Si devices

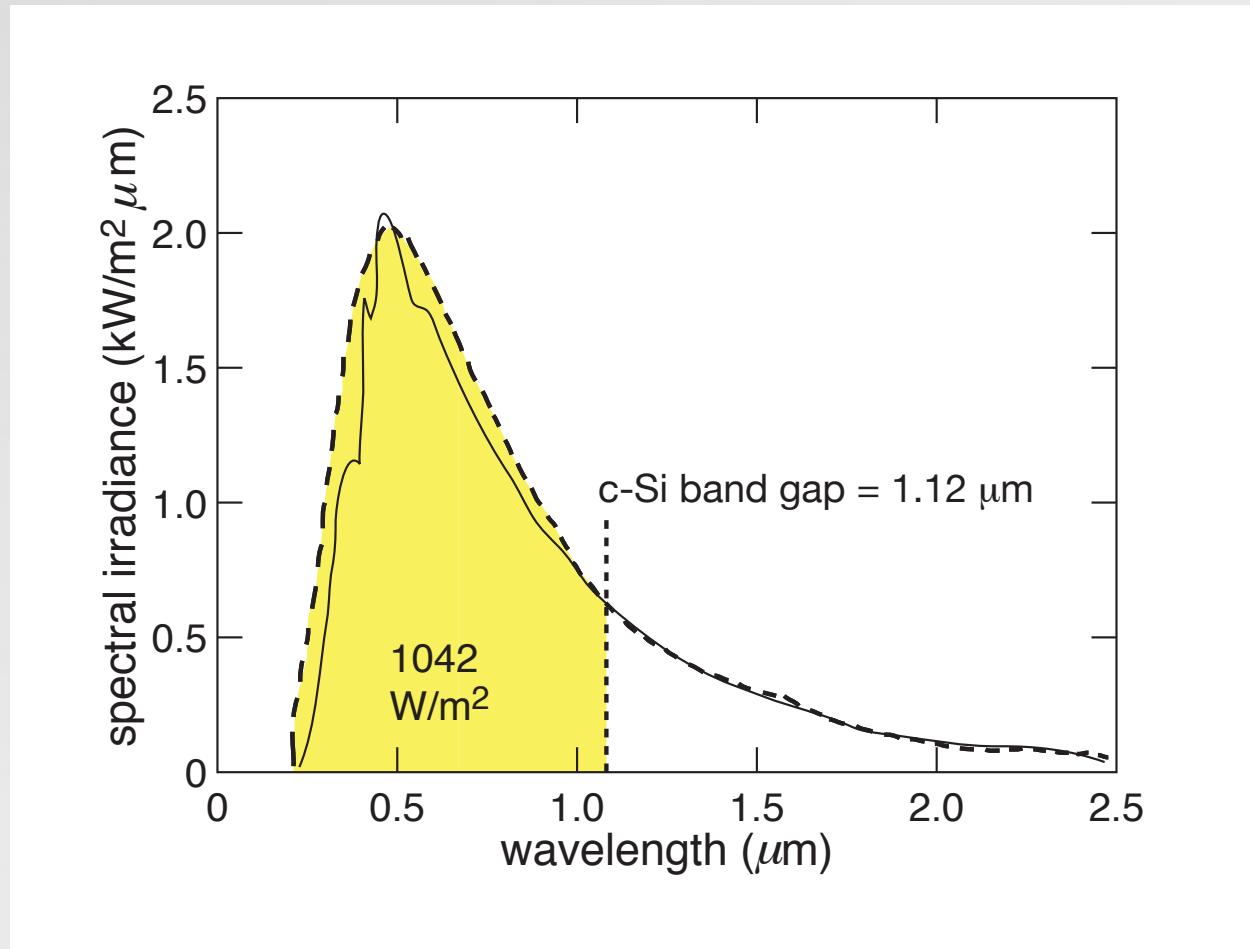
solar spectrum



1 intermediate band

2 Si devices

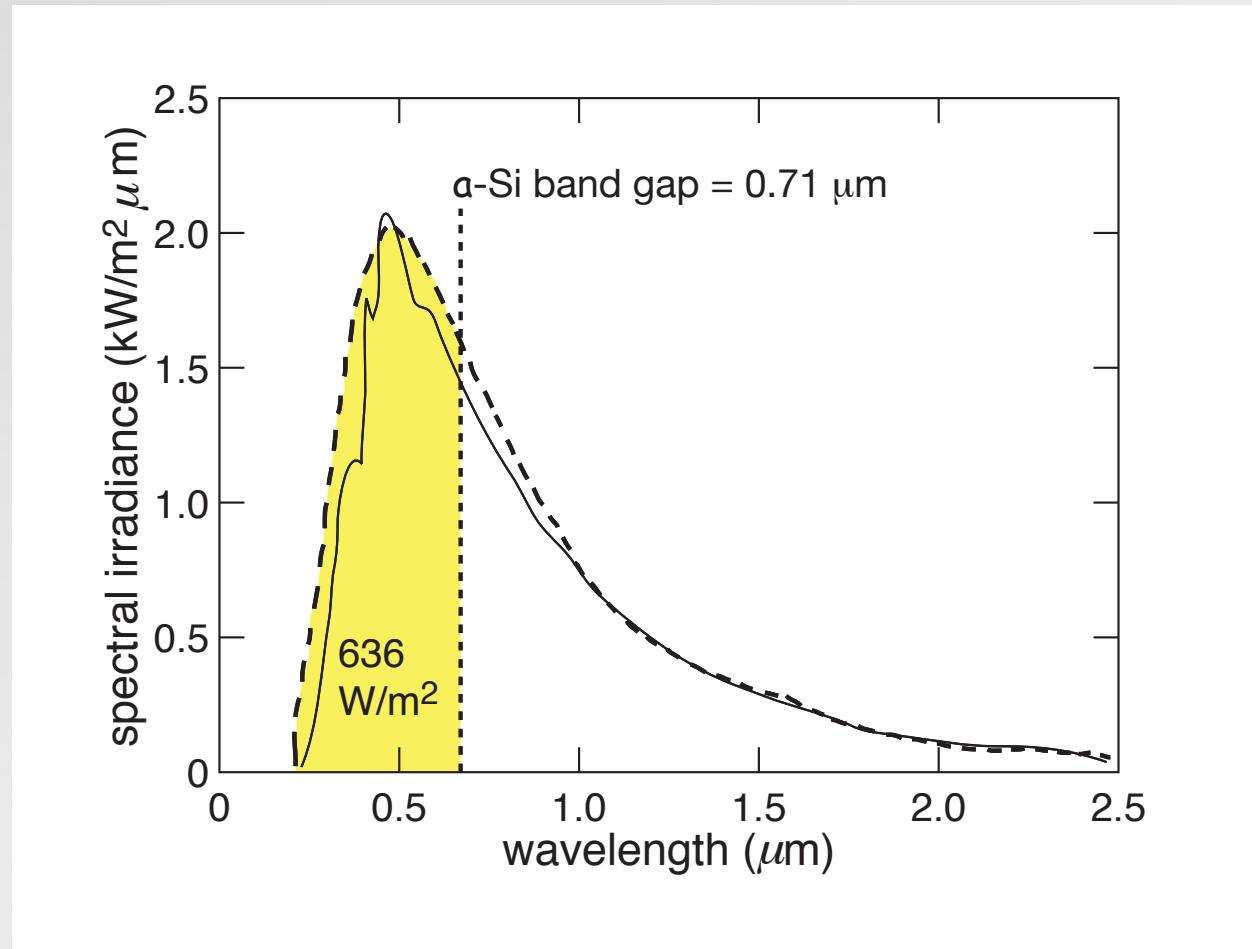
crystalline silicon: transparent to 23% of solar radiation



1 intermediate band

2 Si devices

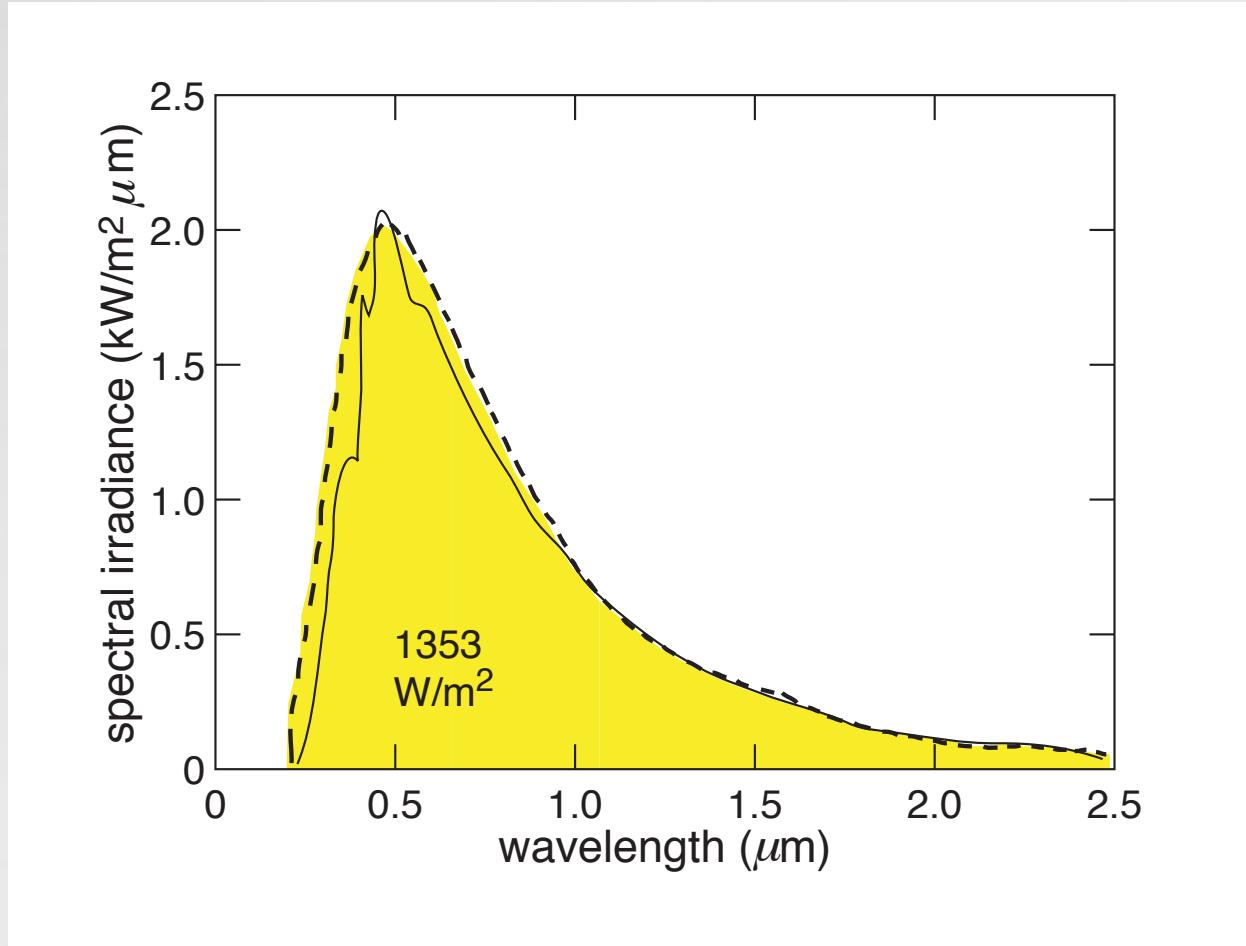
amorphous silicon: transparent to 53% of solar radiation



1 intermediate band

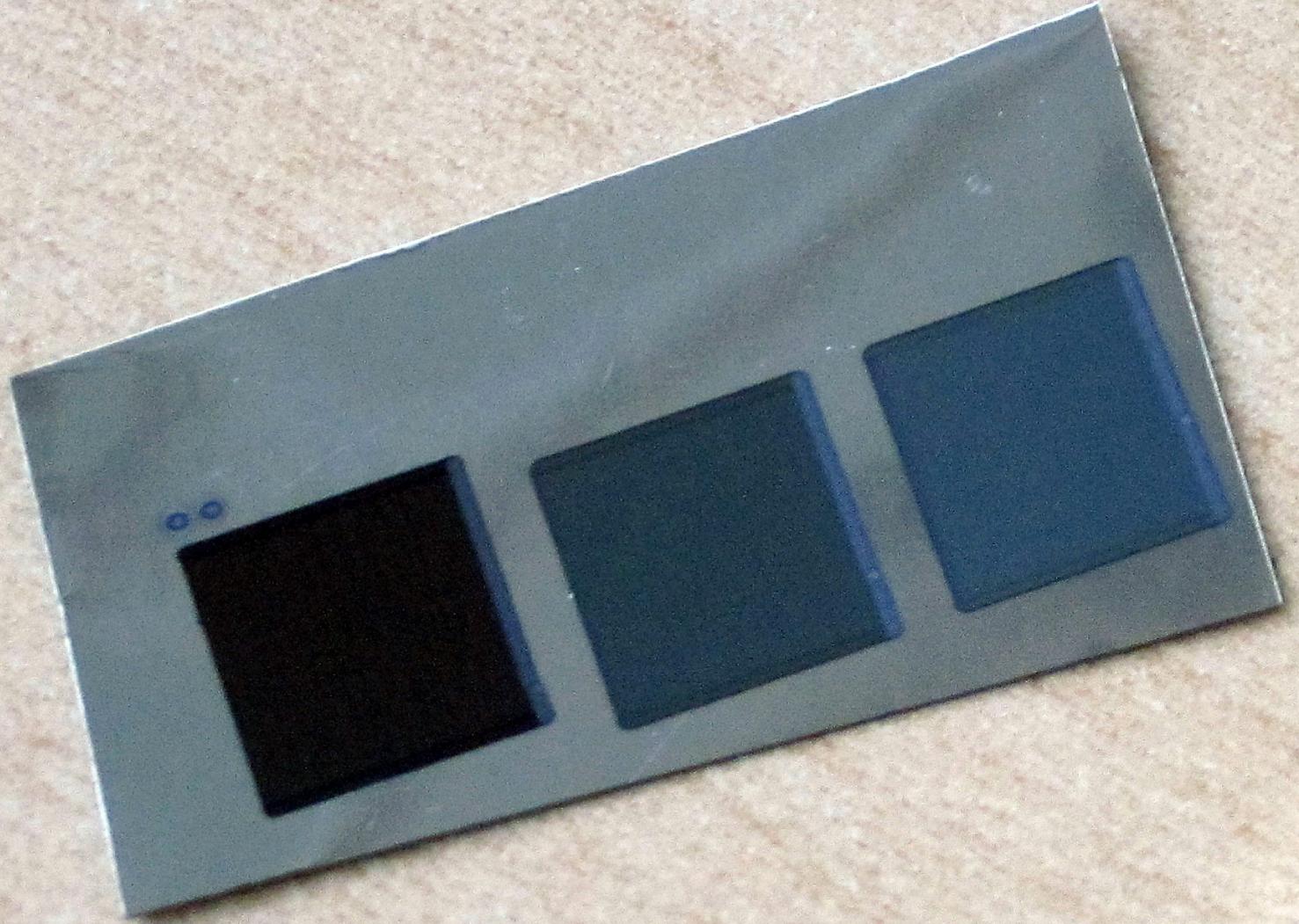
2 Si devices

black silicon: potential to recover transmitted energy



1 intermediate band

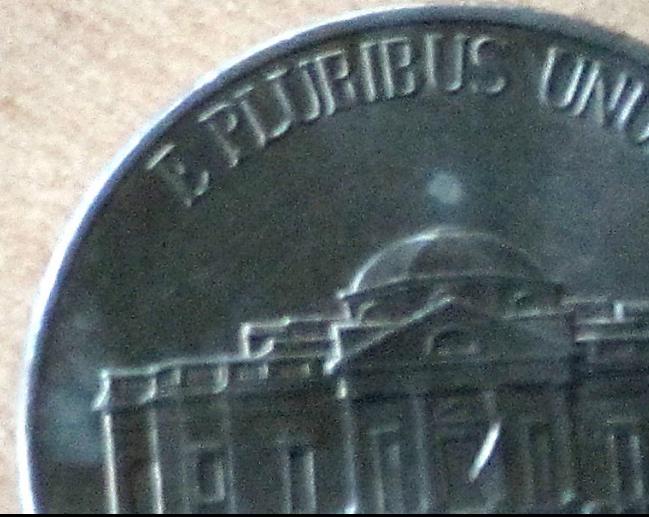
2 Si devices



1 intermediate band

2 Si devices

3 X:TiO₂



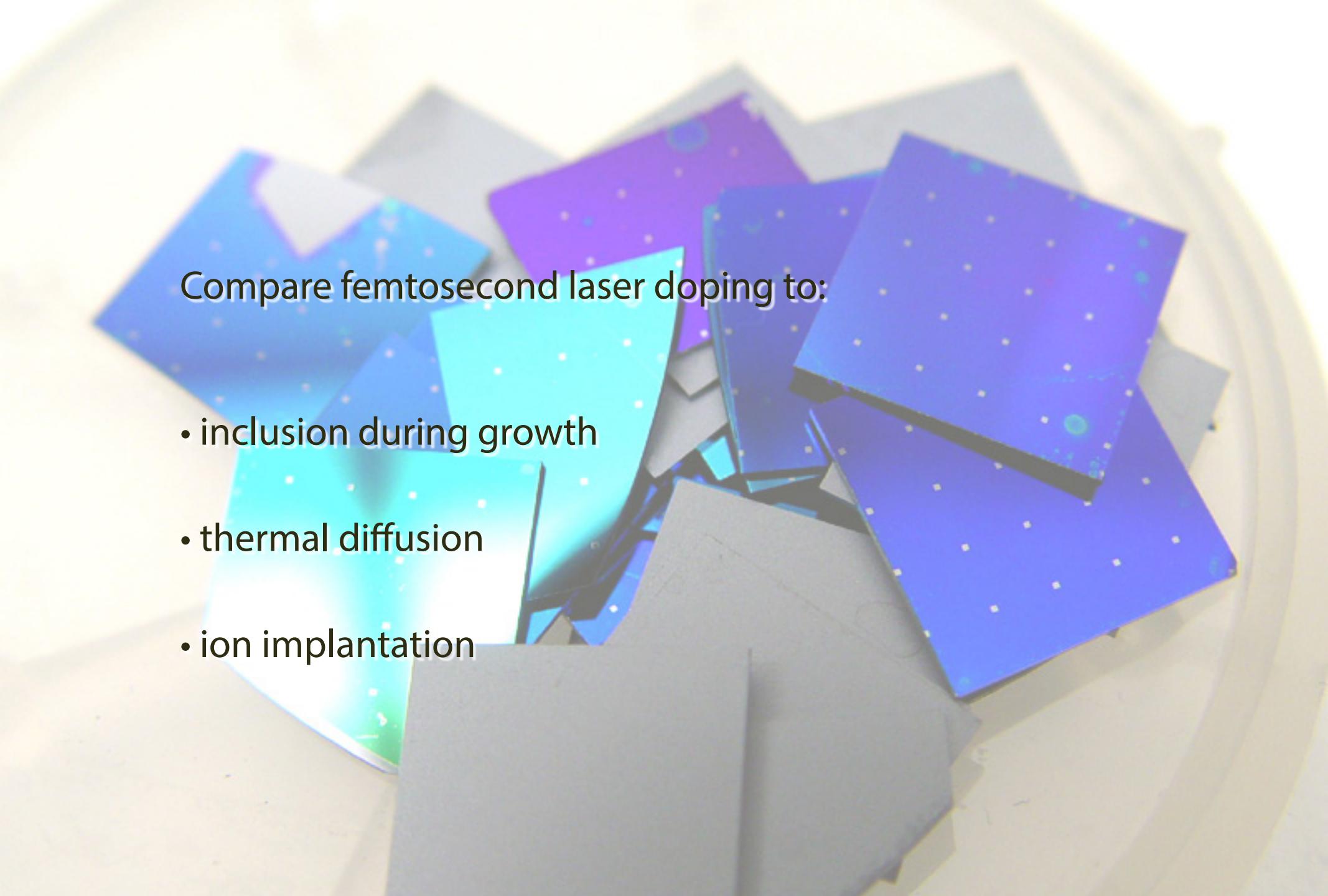


What is different about this process?

1 intermediate band

2 Si devices

3 X:TiO₂



Compare femtosecond laser doping to:

- inclusion during growth
- thermal diffusion
- ion implantation

1 intermediate band

2 Si devices

3 X:TiO₂